Santa Barbara County Air Pollution Control District BACKGROUND PAPER-April 14, 2010

REVISIONS TO

RULE 321. SOLVENT CLEANING MACHINES AND SOLVENT CLEANING

BACKGROUND

The Santa Barbara County Air Pollution Control District (the District) proposes modifications to Rule 321 to implement requirements for solvent cleaning machines and solvent cleaning. To fulfill commitments in clean air plans, the District needs to revise several rules that govern solvent use (Rules 321, 323, 330, 337, 349, 351, 353, and 354). This is the first of several rulemaking efforts to fulfill the solvent control measure commitments and it is focused on revising Rule 321. ^a

^a The 2001 and 2004 Clean Air Plans indicate a new Rule 362 would be adopted to implement the new "general" solvent cleaning control measure. The District later decided to integrate these solvent cleaning requirements within existing Rule 321 and each of the appropriate operation-specific rules. Thus, the emission reductions shown in the 2001 and 2004 Plans for Rule 362 will be obtained by revising the existing rules and the existing control measures.

Rule 321, first adopted on February 24, 1975, applied to all organic solvent degreasing operations that involved the cleaning of surfaces before fabrication, surface coating, electroplating, or any other process. Rule revisions adopted on July 10, 1990 implemented Control Measure R-S-1 of the 1989 Air Quality Attainment Plan. The 1990 changes expanded the equipment design and operating requirements.

The District made the last significant modifications to Rule 321 in 1997. Those changes addressed rule deficiencies identified by ARB and EPA. They also incorporated the model rule provisions recommended in the Air Resources Board Determination of Reasonably Available Control Technology and Best Available Retrofit Control Technology for Organic Solvent Cleaning and Degreasing Operations.[Ref. 1]

The EPA approved Rule 321 for inclusion into the State Implementation Plan on April 2, 1999.[Ref. 2]

PROPOSED REVISIONS

The proposed revised Rule 321 contains solvent reactive organic compound (ROC) content limits, revised equipment requirements for degreasers, and sanctioned solvent cleaning devices and methods. These proposed provisions apply to two general categories: 1) solvent cleaning machines (degreasers) and 2) solvent cleaning done outside of solvent cleaning machines (e.g., wipe cleaning).

The District modeled the revised Rule 321 requirements on those adopted by the South Coast Air Quality Management District (SC) and the San Joaquin Unified Valley Air Pollution Control District (SJV). Staff also included Rule 321 exemptions and other provisions similar to those listed in the Ventura County APCD (VC) solvent rules.

This rulemaking effort also includes modifications to Rule 102 (Definitions) and Rule 202 (Exemptions to Rule 201) to provide rule clarity and for consistency with the revised Rule 321 provisions.

For existing solvent cleaning machines and existing solvent cleaning operations, the deadline to comply with the ROC content limits (and other equipment requirements) is one year from the date of adoption of the amended Rule 321.

The proposed revised Rule 321 requirements demonstrate that the District's Clean Air Plan to attain the California ambient ozone air quality standard provides for expeditious implementation of 'every feasible measure' to reduce ozone precursor emissions (including ROC).

The District expects the proposed revisions to Rule 321 to result in about 0.5 tons per day of ROC emission reduction in Santa Barbara County. The cost-effectiveness of the rule revision is estimated to be between -\$3,320 (cost saving) and \$12,940 per ton of ROC reduced.

Sources that May be Affected by the Changes to Rule 102, Rule 202, and Rule 321

The Rule 321 provisions apply to sources performing solvent cleaning during the production, repair, maintenance, or servicing of parts, products, tools, machinery, equipment, or in general work areas at stationary sources.

There is a wide range of sources that will be affected by the revised rule. Many of the solvent cleaning machines and sources performing solvent cleaning are exempt from the requirement to have a Permit to Operate. Due to their permit-exempt status, the District is unable to specifically identify all sources using solvent cleaning machines and/or performing solvent cleaning.

Stationary sources that likely have solvent cleaning machines and/or are performing solvent cleaning that will be subject to the proposed revised Rule 321 are shown:

- 1. generically in Appendix A, and
- by facility or company/agency name in Appendix B-data gleaned from the District permitting and innovative technology programs.

Staff estimates that there may be over 1,000 solvent cleaning machines in use at repair shops and manufacturing and production facilities in Santa Barbara County. Further, the number of sources performing solvent cleaning that will be subject to Rule 321 is estimated to be in the range of 100 to 200.

Solvent cleaning associated with other District operation-specific rules (e.g., 320, 325,326, 330, 337, 343, 344, 349, 351, 353, or 354) will be exempt from the Rule 321 solvent cleaning provisions. If a source subject to one of the other operation-specific rules is

performing solvent cleaning <u>and</u> using a solvent cleaning machine:

- the solvent cleaning machine is subject to Rule 321 requirements.
- the solvent cleaning (done outside of the solvent cleaning machine) is exempt from Rule 321.

Rule 102, Definitions

The District proposes to add and modify several definitions that are used in various parts of the rulebook. Appendix C contains an annotated proposed amended Rule 102 with information on the origin of the new and revised definitions.

Rule 202, Exemptions to Rule 201

The District proposes to make minor revisions to Sections D, I, and U of Rule 202 (and the Rule 210 title throughout the rule). The reasons for such changes are outlined in the annotated proposed amended Rule 202 (Appendix D).

Rule 321, Solvent Cleaning Machines and Solvent Cleaning

Changes to Rule 321 will require more rigorous emission control techniques for solvent cleaning machines and establish solvent ROC content limits for solvent cleaning and cold solvent cleaners. Also, vapor cleaning machines using a solvent with an ROC content greater than 50 grams per liter shall require additional emission reducing devices.

Appendix E summarizes the significant revisions to Rule 321 and Appendix F provides an annotated proposed amended Rule 321.

Appendix O provides the proposed amended rules without strikeout and underlined changes.

EMISSION REDUCTION / COST-EFFECTIVENESS

ROC Emission Reductions

Appendix G, Table 1 provides a breakdown of the projected emissions reductions for year 2011. Table 1 indicates that the total emission reduction from modifying Rule 321 is about 214 tons of ROC per year. Table 2 provides a comparison of the data developed for the 2007 Clean Air Plan and the currently projected emission reductions for calendar years 2015 and 2020.

Due to changes in the project, activity factors, and the inventory, the currently projected emission reductions for calendar year 2015 are about 370 pounds of reactive organic compounds per day less than those indicated in the 2007 Clean Air Plan. Despite the ROC emission reduction shortfall, the currently projected emission reduction for calendar year 2015 is about 195 tons per year, which

represents a very large and important emission reduction for Santa Barbara County.

At the request of the regulated community, the District included emissions breakdowns for various categories (Tables 3 and 4). Although the contribution of emissions from point sources is relatively small, Rule 321 needs to apply to point sources per the "adopt every feasible measure" requirement.

Cost-Effectiveness

The annual costs and cost-effectiveness of switching from high-ROC surface cleaning to low-ROC surface cleaning are shown in Appendix G, Tables 5 and 6. The cost-effectiveness data ranges from -\$3,320 (savings) to \$12,940 per ton of ROC reduced.

According to the SC cost-effectiveness analysis for the 1997 Rule 1122 amendments, the overall cost-effectiveness was \$1,379 per ton of ROC reduced for solvent cleaning machine modifications. That analyses included the costs of vapor degreaser freeboard extension kits (\$2,000 per unit), automated parts handling systems (\$4,000 per unit), and retrofitting extended freeboards and freeboard chillers (\$7,100 per unit).

The cost-effectiveness for solvent cleaning (changing from high ROC solvents to compliant solvents) ranges between -\$1,670 (cost savings) to \$3,340 per ton of ROC reduced.[Ref. 3]

Incremental Cost-Effectiveness

Health and Safety Code Section 40920.6 requires an incremental cost-effectiveness analysis for a regulation that identifies more than one control option to meet the same emission reduction objectives. Incremental cost-effectiveness is defined as the difference in costs divided by the difference in emission reductions between one level of control and the next more stringent level of control.

Rule 321 regulates solvent cleaning machines and solvent cleaning. Compliance by equipment modifications and the substitution of materials is expected. No alternative emission control scenario is available.

ANALYSIS OF EXISTING FEDERAL AND DISTRICT REGULATIONS

Appendix H contains the written analysis required by the California Health & Safety Code Section 40727.2 requirements.

COMMENTS AND PUBLIC MEETINGS

Comments

The District received and responded to extensive comments on the proposed revised rules during the development stages. Staff consolidated these comments and responses into Appendix I, Clarification of Rule Issues. Comments received during the formal public comment period preceding the Board adoption hearing on the proposed rule changes and staffs response to these comments will be presented to the District Board of Directors as part of the rule adoption process.

Public Meetings

CLEAN SLATE WORKSHOP, MAY 21, 2003

Industry representatives were concerned about requiring low-ROC solvents for surface preparation prior to vehicle painting. They indicated that past attempts to use compliant solvents to remove road tar from vehicles were not successful.

One industry representative requested that the rule provide an exemption for isopropyl alcohol (IPA). Further, if IPA use is subject to the rule, hospitals, schools, technical universities, and prisons (that have auto body shops) should be subject to the rules.

A concern about making the provision apply to ozone depleting and global warming compounds was expressed.

An oil industry representative mentioned that there needs to be an exemption for cleaning analytical equipment or a provision to allow the use of hexane. Additional discussions involved rule applicability, exemptions, enforcement, and recordkeeping requirements.

SCOPING WORKSHOP, AUGUST 5, 2008

Attendees voiced concerns about hospital use of isopropyl alcohol for general surface cleaning and how these emissions would not be subject to the proposed amended rule. It was agreed that the rule support document should mention the emission rate from such use. Further, a specific hospital exemption should be added.

Turbine cleaning activities and the applicability of the gas/liquid-path cleaner provisions in the existing rule were discussed. The District requested that a description of the turbine cleaning operation be provided.

Platform operators indicated there are concerns that the use of low-ROC solvents will present a water quality discharge compliance issue. Their current practice is to clean up crude oil spills by using petroleum-based solvents. The run-off of waste solvent is collected and directed into the petroleum product stream. Under the proposed requirements, the wastewater from use of aqueous solvents would need to collected and treated differently. District staff indicated that additional research on this issue will be performed.

There were some discussions on the general approach being taken to regulating solvent use:

- Some representatives were concerned about the command and control approach taken by other air districts and the move to outlaw and criminalize certain chemicals, especially when the sources using the materials are subject to District permits.
- 2. Another concern raised by the regulated community was that some solvent cleaning permits have conditions limiting solvent use in pounds of emissions per day; the reduction in the ROC per gallon limit won't affect the permit conditions. Also, the permitted emissions have been offset; the source has paid for the right to emit at a certain level, and should not be required

to lower the ROC emissions by the revised rule provisions.

On issue 1, staff explained that we were proposing to meet the Clean Air Plan requirement to implement every feasible control measures. One indicator of a rule meeting the every feasible measure requirement is if the technique has been successfully adopted and implemented in other air districts. The proposed revised requirements have been adopted in the South Coast Air Quality Management District and the San Joaquin Valley Unified Air Pollution Control District for quite some time. The ROC limits we will be proposing will take into account the needs for specific industries. Further, many of the devices to be controlled by the revised rule are permit exempt.

Regarding issue 2, there was discussion on the differences between prohibitory rule provisions and the New Source Review rule provisions.

The regulated community wants the 55 gallons per year wipe cleaning permitting threshold in Rule 202.U.3 to be increased to acknowledge or address the requirement to use lower ROC solvents. A source should not be limited to the 55 gallons per year provision, which was intended for high-ROC solvents. The District indicated that it did not envision issuing more permits based on the Rule 321 changes. Further, staff would look at ways to address the incongruity of requiring permits for currently unpermitted solvent wipe cleaning operations that would exceed 55 gallons per year as a result of using Rule 321-compliant low-ROC solvents, but have decreased emissions as compared to high ROC solvents.

The need for Rule 321 exemptions was also discussed. Some participants urged the District to provide an exemption for wipe cleaning with isopropyl alcohol. Others recommended that the San Joaquin Valley Unified Air Pollution Control District 55 gallons per year exemption be included.

Clarification of the proposed ROC solvent limit for aerospace was requested. There is a concern on what the ROC limit will be for solvents used in cleaning clean rooms. Staff indicated that they would look into how other air districts have handled such specific cleaning operations.

RULE DEVELOPMENT WORKSHOP, JUNE 25, 2009

Comments received during this workshop included:

- 1. Concerns on the emission inventory, calculations for the emission reductions, and emissions from janitorial services and hospital use of IPA.
- 2. The relative low emissions and emission reductions projected from stationary sources in comparison to those from area sources.
- 3. Concerns on how the District will enforce the requirements on unpermitted (area) sources.
- Desires to get clarification on certain aspects of the rule; suggestions on clarifying text and additions to the rules and/or the background paper.
- How certain exemptions would not be useful without revisions.
- 6. Requests that the District not make the Rule 321 requirements applicable to solvents that contain toxic air contaminants (i.e., under the proposed

amended rules, solvents otherwise exempt due to having a low ROC content would be subject to the rule if they contained TACs above two percent).

Staff indicated that they would continue to work with the regulated community on the issues and respond to their requests for information. Appendix M contains a list of toxic air contaminants.

COMMUNITY ADVISORY COUNCIL MEETING, SEPTEMBER 23, 2009

The District asked the Community Advisory Council (CAC) to provide recommendations on two Rule 321 rulemaking key issues:

- 1. Should the project include toxic air contaminants (TACs)?
- 2. Should the "general solvent use" limit be 25 or 50 grams of ROC per liter?

The CAC passed motions recommending that the project not include TACs and that the limit be at 50 grams per liter.

COMPARISON OF ADJOINING APCD RULES

Appendix J provides a comparison of the San Joaquin Valley APCD, Ventura County APCD, and the San Luis Obispo County APCD rules on permit exemptions and requirements for solvent cleaning machines and solvent cleaning. Basically, there are general similarities with some minor differences between the adjoining air district rules and the proposed amended rules.

IMPACTS OF THE REVISED RULES TO INDUSTRY AND THE DISTRICT

Details of the impacts from the rule revisions are summarized in Appendix K. The rule revisions will cause impacts to the regulated community and District staff by:

- 1. Requiring a permit for a source that uses certain compounds in excess of one gallon per year.
- 2. Expanding the scope of applicability of Rule 321 to include solvents that contain toxic air contaminants.
- 3. Requiring the application and verification of control techniques to comply with the Rule 321 requirements.
- 4. Increasing or causing new operating and monitoring costs.
- 5. Reducing solvent costs for some sources due to the use of lower-ROC content solvents.

To assist sources in determining attributes of various solvents, the District has included a Solvent Information Table in Appendix N.

REFERENCES

- Air Resources Board, Determination of Reasonably Available Control Technology and Best Available Retrofit Control Technology for Organic Solvent Cleaning and Degreasing Operations, July 18, 1991.
- 2. Federal Regulation citation: 63 FR 5922, April 2, 1999.
- 3. South Coast Air Quality Management District, Final Staff Report for Proposed Amendment to Rule 1122 - Solvent Degreasers, June 6, 1997.

APPENDICES

Appendix A:	Generic Types of Stationary Sources that May Have Solvent Cleaning Machines or May be
	Performing Solvent Cleaning that Will be Subject to the Amended Rule 321
Appendix B:	Facilities that May Have Solvent Cleaning Machines or May be Performing Solvent Cleaning
	Subject to Proposed Amended Rule 321
Appendix C:	Annotated Proposed Amended Rule 102, Definitions
Appendix D:	Annotated Proposed Amended Rule 202, Exemptions to Rule 201
Appendix E:	Summary of Significant Changes to Rule 321, Solvent Cleaning Machines and Solvent Cleaning
Appendix F:	Annotated Proposed Amended Rule 321, Solvent Cleaning Machines and Solvent Cleaning
Appendix G:	Summarized Data on Emission Reductions, Emissions, and Cost-Effectiveness
Appendix H:	Identification of Existing Federal and the Santa Barbara County Air Pollution Control District
	Regulations that Apply to the Same Equipment or Source Type Covered in Rule 321
Appendix I:	Clarification of Rule Issues
Appendix J:	Comparison of the Adjoining Air District Permitting and Prohibitory Rules for Solvent Cleaning
	Machines and Solvent Cleaning
Appendix K:	Impacts from the Revised Rules
Appendix L:	Flowchart Overviews of Proposed Amended Rules 202 and Rule 321
Appendix M:	List of Toxic Air Contaminants
Appendix N:	Solvent Information Table

Proposed Amended Rules Without Strikeout and Underlined Formatting

Appendix O:

Appendix A Santa Barbara County

Generic Types of Stationary Sources that May Have Solvent Cleaning Machines or May be Performing Solvent Cleaning that Will be Subject to the Amended Rule 321

Aircraft and Aerospace Vehicle Parts and Products Manufacturing Facilities

Airports

Agricultural Mills

Asphaltic Concrete Batch Plants

Automobile Repair Shops

Bulk Fuel Plants

Concrete Batch Plants

Correctional Facilities, Prisons, and Jails

Electronic Device Manufacturers

Gas Stations with Maintenance Bays

Landfills

Lawnmower Repair Shops

Machine Shops

Manufacturing Plants

Medical Device Manufacturers

Military Installations

Mineral Processing Plants

Offshore Platforms

Oil and Gas Processing Facilities

Oil and Gas Pipelines and Pump Stations

Pharmaceutical Manufacturers

Refineries

Repair Shops

Satellite Parts, Products, and Payload Manufacturing/Handling Facilities

Silicone Manufacturing Plants

Spaceports

Tire Shops

Wastewater Treatment Plants

Water Filter Manufacturing Facilities

Water Treatment Plants

Wineries & Breweries

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Appendix B Santa Barbara County Facilities that May Have Solvent Cleaning Machines or May be Performing Solvent Cleaning Subject to Proposed Amended Rule 321^a

Table 1. FACILITIES LISTED IN THE AIR POLLUTION CONTROL DISTRICT INTEGRATED DATA SYSTEM

FID	COMPANY OR AGENCY	Sol. Cln ^b	SCM ^b	FID	COMPANY OR AGENCY	Sol. Cln ^b	SCM ^b
02463	Advanced Vision Science	X	X	08006	DCOR, LLC., Platform C	X	X
10084	Allergan Corporation	X	X	08012	DCOR, LLC., Platform Habitat	X	X
01325	Arguello, Inc., Gaviota Oil Heating Facility	X		08007	DCOR, LLC., Platform Henry	X	X
08013	Arguello, Inc., Platform Harvest	X	X	08005	DCOR, LLC., Platform Hillhouse	X	X
08014	Arguello, Inc., Platform Hermosa	X	X	03778	Den-Mat Corp.	X	
08015	Arguello, Inc., Platform Hidalgo	X	X	03858	Digital Instruments		X
01152	Bardex Corporation		X	08709	Dupont Displays		X
03794	BEGA/US	X		10307	Dupont Displays (600 Ward Dr)		X
03314 (+ Others)	BreitBurn Energy	X		01074	E & B Natural Resources	X	
10291	Calient Networks, Inc	X		01477	Electro Optical Industries	X	
00012	Celite		X	01480	Essex Electronics, Inc.	X	X
01294	Channel Industries, Inc.	X		01482	ExxonMobil SYU Project, Las Flores Canyon	X	X
04545	Cree, Inc.	X		08018	ExxonMobil SYU Project, Platform Harmony	X	X
08003	DCOR, LLC., Platform A	X	X	08019	ExxonMobil SYU Project, Platform Heritage	X	X
08004	DCOR, LLC., Platform B	X	X	08009	ExxonMobil SYU Project, Platform Hondo	X	X

^a Appendix B information is based on 2007 data from several District programs and is not intended to be an all-inclusive listing of facilities to be subject to the revised Rule 321. The mailing list for this rulemaking project includes over 800 potential sources that may be subject to the proposed amended Rule 321.

^b Sol. Cln = Solvent Cleaning and SCM = Solvent Cleaning Machine.

FID	COMPANY OR AGENCY	Sol. Cln ^b	SCM ^b	FID	COMPANY OR AGENCY	Sol. Cln ^b	SCM ^b
03170	ExxonMobil SYU Project, POPCO Plant	X	X	08934	Pacific Scientific, EKD	X	X
09664	First Nano, Inc.	X		03095	Plains Exploration & Production Co., Lompoc Oil & Gas Plant	X	X
08676	Foristar Methane Group, LLC		X	08016	Plains Exploration & Production Co., Platform Irene	X	X
3211 (+ Others)	Greka Oil & Gas	X		03890	Raytheon, Bldg B-8	X	X
10453	GRT, Inc.	X		04140	Raytheon, Bldgs B1, B2, B3, and B6	X	X
04487	Helix Medical, Inc., Medical Device Mfg		X	01971	Raytheon, Hollister	X	X
09745	Indigo Systems	X	X	08742	Raytheon, Lompoc	X	
10789	Inlustra Technologies, LLC	X		09684	Raytheon, VOCs		X
10867	Innovative Micro Technology, Inc. (IMT)	X		04574	Renco Encoders, Incorporated	X	X
01634	International Transducer Co.	X	X	04621	Silicone Technology	X	
04583	Karl Storz Imaging, Incorporated		X	03750	Skate One Corp.		X
01670	Kilovac Corporation	X	X	04644	Sonatech, Inc.	X	
09424	Lockheed Martin (Santa Barbara Focalplane - operator)		X	10436	Space Exploration Technologies	X	
04455	Magretech, Incorporated	X		08698	Spaceport Systems International		X
04635	Medtronic PS Medical		X	02758	Special Technologies Laboratory		X
01820	Microwave Applications Group		X	10341	Superconductor Technologies, Inc.	X	
06100	National Aeronautics & Space Admin.	X	X	01900	The Okonite Company		X
01880	Neal Feay Company	X		03640	Trisep Corporation	X	
02361	Nusil Technology	X		03970	United Launch Alliance, LLC	X	
04617	Pacific Hydraulic Systems	X	X	00206	United Launch Alliance, LLC	X	

FID	COMPANY OR AGENCY	Sol. Cln ^b	SCM ^b	FID	COMPANY OR AGENCY	Sol. Cln ^b	SCM ^b
00201 (+ Others)	Vandenberg Air Force Base, Solvents (general)		X	04003	Venoco, Inc., Ellwood Marine Terminal	X	
10105	Veeco Instruments	X		00028	Venoco, Inc., Ellwood Onshore Facility	X	
03035	Venoco, Inc., Beachfront Lease	X		03203	Venoco, Inc., Jovalan Barge	X	
00027	Venoco, Inc., Carpinteria Gas Plant	X		03105	Venoco, Inc., Platform Holly	X	
04138	Venoco, Inc., Carpinteria Pipeline Facility	X		01065	Venoco, Inc., Seep Containment Device	X	

Table 2. AUTOMOBILE REPAIR FACILITIES

A & A Import Service	Anacapa Mobile Service	AutoProfessionals	Bob's Import Auto Service
A & B Glass	Anderson Custom Boats	Ayers Repairs	Bowman's Auto Repair
A 1 Smog & Repair	Andy's Mobil Lube & Auto Service	Bear Automotive	Bruce's Auto Repair
AAMCO Transmission	Anvil Motor Sports	Ben's Transmission Service	Buellton Union Elementary School District
Advanced Automotive	APW Automotive Services	Bianchi Motor & Auto Body	Burley's Bimmer Service
Advanced Automotive Services	A-Smog-It	Big Brand Tire Co., Carrillo St.	Bush's Automotive Repair
AGS Rebuilders	ATG Automotive Technicians Group	Big Brand Tire Co., Fairview Ave.	Byrd Harvest
Airport Motors	Auto Parts Restoration	Big O Tires	C & S Automotive
Al Williams Carburetor & Electric Co.	Auto Pro	Blanquette Automotive	Carburetor & Electric Co.
Alamar Automotive	Automotive Concepts	Bob Joehnck Automotive	Carpinteria Automotive
Alisal Guest Ranch and Resort (Alisal Ranch Golf Course)	Automotive Service Center	Bob Woolever's Tire Shoppe, Hollister Ave.	Carpinteria Union School District
Alisal Guest Ranch and Resort (Alisal River Golf Course)	Automotive Systems Laboratory, Inc.	Bob's Auto Salon	Casey's Garage
Allan Hancock Community College	Automotive Tech Group, Inc.	Bob's Garage	Cetti Services- Goleta

Channel City Auto Body	Dos Pueblos High School	H&R Motors	Kennedy's Automotive Center
Channel City Engineering	East-West Motors	Haik's German Autohaus	Klaus Braun Automotive
City of Santa Barbara Motor Pool	Eric Krebs Automotive	Hein Motor Repair	Lang Motors
Clark Motors	Fairview Shell Auto Care	Higgins Muffler & Brake	Lara Auto Repair
Coast Muffler & Brake	Fairview Unocal Service & Carwash	Hughes Automobile Company	Larry's Auto Parts
Coast Village Shell	Falcon Crest Tire & Service	Ian's	Las Positas Mobil Service
Coastline Auto Repair	Fast Lane Oil Change, Milpas St.	Import Auto Parts Machine Shop & Parts Store	Loesche's Custom VW Service
Cooper Automotive	Fast Lane Oil Change, State St.	Imported Auto Service	Lompoc Union School District
Cory Motors	Fast Undercar, Inc.	Independent Lexus & Infiniti	Love's Towing
Cutter Motors	Firestone Tire & Service Centers	Iversen Motor Co.	Mac Tools
Cycle Werks	Fred Import Auto Service	J & S East Valley Garage	Mahneke Motors
D & D Truck Service	Garcia's Auto Repair	J V Enterprises	Mariah Motorsports- Design Energy, Inc.
D & G Automotive	George Thorpe	JAE	Martyn Motors
Dal Pozzo Tire Corp., Chapala St.	GM Auto & Smog	Jenson Chevron Service	McCormix Corporation
Dal Pozzo Tire Corp., Milpas St.	Goleta Chevron Service	Jiffy Lube, Hollister Ave.	MD Auto Repair
Dal Pozzo Tire Corp., Pine Ave.	Goleta Radiator Service	Jiffy Lube, De La Vina St.	Mel Clayton Ford
Dave Scholl automotive	Goleta Transmission	Jim Vreeland Ford	Mesa Union 76
Dave's Auto Repair	Goleta Union School District	John Howe West, Inc.	Michael Fitzpatrick Auto Body
De Nunzio Racing Products	Goodyear Tire Center	John Hurley Automotive	Mike Loredo Chevron
Der Volks Werks	Graham Chevrolet- Oldsmobile-Cadillac	John's Mobil	Milano Motors
Dimauro's Honda Service Center	Granny's Garage	Jose Antonio Huerta	Mireles Automotive
Discount Tire Centers	Guadalupe Union School District	Ken Symer Automotive	Mission Uniform Service

Mitchell International	Raffetto & Co.	Santa Barbara MTD	Star-Tech Auto Repair
Motor Brake & Wheel Svc	Razon Transmission	Santa Barbara Nissan, LLC	Stirling Mobile Repair
Muller & Goss	Reliable Repair	Santa Barbara Radiator	Stuttgart Motors
Muñoz's Auto Repair	Richard's Accurate Import Serv.	Santa Barbara School District	Superior Brake & Alignment, Fairview Ave.
National Motors Mobile Repair	Rick's Auto Repair	Santa Barbara Smog Shop	Superior Brake & Alignment, Figueroa St.
Nespor's University Auto House	Rio Vista Chevrolet	Santa Barbara Transmission Service	Swedemaster
O'Brien Maintenance & Repair	Risdon's 76 Service	Santa Barbara Transportation	Tam's Imported Car Repair
Olive Mill 76 Service Center	Rizzoli's Automotive	Santa Barbara Transportation, Hollister Ave.	Technomotive
Olivera's Repair	Rob's 4 Wheel Drive & Fab	Santa Barbara Transportation, Jason Way	The Auto Works of Santa Barbara
Orcutt Union School District	Rob's Union 76	Santa Barbara Volkswagen	The Engine Company
Oswald's Auto Repair	Rosebro Garage	Santa Maria Area Transit	The International Autohaus
P. C. Automotive	S D Autoparts	Santa Maria Joint School District	The Jag Shop
Pep Boys	San Marcos High School	Santa Maria School District	The Shop
Performance Rebuilders	Santa Barbara Auto Refinishing	Santa Ynez Valley School District	The Smog Center
Perry Lincoln Mercury Mazda	Santa Barbara Automotive	SB American Fuel & Service	TM Auto Repairs
Perry's Auto Parts & Service	Santa Barbara Chrysler Plymouth Jeep Eagle	Schneider Autohaus, Santa Barbara	Toby's Engine Parts
Pichard's Auto Repair	Santa Barbara City College	Schneider Autohaus, Lompoc	Tor's Saab
Pickle Auto Repair	Santa Barbara County, Vehicle Operations Division	Scott's Mobile Automotive Repair	Toyota of Lompoc
Powell Garage	Santa Barbara County, Vehicle Operations Division - North County	Smitty's Towing	Toyota of Santa Barbara
Precision Auto Body and Paint	Santa Barbara Electronic Service	Smog-It	Toyota of Santa Maria
Precision Automotive	Santa Barbara Honda	Snap On Tools, Cadiz Ct.	Trans-King Transmissions

Turnpike Unocal	United States Dept. of Agriculture, Forest Service, Los Padres	Voigt's Truck & Auto Service
	National Forest	
Under The Hood Automotive	Valley Automotive Services	Westside Auto Repair
Union 76	Village Automotive Repair	Winning Makes

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Appendix C Santa Barbara County Annotated Proposed Amended Rule 102, Definitions

RULE 102. DEFINITIONS. (Adopted 10/18/1971, revised 1/12/1976, readopted 10/23/1978, revised 7/11/1989, 7/10/1990, 7/30/1991, 7/18/1996, 4/17/1997, 1/21/1999, 5/20/1999, 6/19/2003, 1/20/2005, 6/19/2008, and 1/15/2009), and [date of revised rule adoption])

These definitions apply to the entire rulebook. Definitions specific to a given rule are defined in that rule or in the first rule of the relevant regulation. Except as otherwise specifically provided in these Rules where the context otherwise indicates, words used in these Rules are used in exactly the same sense as the same words are used in Division 26 of the Health and Safety Code. [Link to Note No. 1]^a

 $[\ldots]$

"Application Equipment" means a device or equipment used to apply solvent, sealant, adhesive, coating, ink, or polyester resin materials. [Link to Note No. 2]

 $[\ldots]$

"Coating" means a material applied onto or impregnated into a substrate for protective, decorative, or functional purposes. Such materials include, but are not limited to, paints, varnishes, sealers, and stains.

 $[\ldots]$

"Cured Adhesive, Cured Coating, or Cured Ink" means an adhesive, coating, or ink that is dry to the touch.

 $[\ldots]$

"Degreaser" has the same meaning as "Solvent Cleaning Machine." [Link to Note No. 3]

[...]

"Flexographic Printing" means any printing method in which the image area is raised relative to the nonimage area and utilizes flexible rubber or other elastomeric plate and rapid drying liquid inks. [Link to Note No. 4]

[...]

"Janitorial Cleaning" means the cleaning of building or facility components including, but not limited to, floors, ceilings, walls, windows, doors, stairs, bathrooms, furnishings, and exterior surfaces of office equipment; excluding the cleaning of work areas associated with:

- 1. research and development, manufacturing, and repair activities; and
- 2. laboratory tests and analyses (including quality assurance and quality control activities) and bench scale projects.

[...]

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^a Notes concerning the proposed new Rule 102 definitions are within a table starting on Page C-3. When using a computer to view this material, use a link to get to a note by clicking the left mouse button over the "Link to Note No." text.

"Organic Solvents" means organic materials, including diluents and thinners which are liquid at standard conditions and which are used as, dissolvers, viscosity reducers or cleaning agents, except that such materials which exhibit a boiling point, as measured using ASTM D 1078-05, "Standard Test Method for Distillation Range of Volatile Organic Liquids," ASTM International, higher than 220°F at 0.5 millimeter mercury absolute pressure or having an equivalent vapor pressure shall not be considered to be <a href="https://organic.gov/organic.g

 $[\ldots]$

"Photochemically Reactive Solvent" means any <u>organic</u> solvent with an aggregate of more than 20 percent of its total volume composed of the chemical compounds classified below or which exceeds any of the following individual percentage composition limitations, referred to the total volume of <u>organic</u> solvent;

- 1. combination of hydrocarbons, alcohols, aldehydes, esters, ethers or ketones, having an olefinic or cyclolefinic type of unsaturation: 5 percent, or
- 2. combination of aromatic compounds with 8 or more carbon atoms to the molecule, except ethylbenzene: 8 percent, or
- 3. combination of ethylbenzene, ketones having branched hydrocarbon structures, trichloroethylene or toluene: 20 percent.

Whenever any organic solvent or any constituent of an organic solvent may be classified from its chemical structure into more than one of the above groups of organic compounds, it shall be considered as a member of the most reactive chemical group, i.e., that group having the least allowable percent of the total volume of <u>organic</u> solvents. [Link to Note No. 5]

 $[\ldots]$

"Reactive Organic Compound" means any volatile compound containing at least one (1) atom of carbon, except for the following exempt compounds: [Note: Compounds and text shown below in **bold** are additions to the "reactive organic compound" definition.]

- 1. acetone
- 2. ammonium carbonate
- 3. carbon dioxide
- 4. carbon monoxide
- 5. carbonic acid
- 6. dimethyl carbonate
- 7. ethane
- 8. metallic carbides or carbonates
- 9. methane
- 10. methyl acetate
- 11. methyl chloroform (1,1,1-trichloroethane)
- 12. methyl formate; HCOOCH₃
- 13. cyclic, branched, or linear completely methylated siloxane compounds

Methylated siloxane compounds shall be assumed to be absent from a product or process unless a manufacturer or facility operator identifies the specific individual compounds (from broad classes of these compounds) and the amounts present in the product or process, and provides an Environmental Protection Agency approved test method which can be used to quantify the specific compounds.

- 14. methylene chloride
- 15. Parachlorobenzotrifluoride
- 16. perchloroethylene (tetrachloroethylene)
- 17. the following four classes of perfluorocarbon (PFC) compounds:

- a. cyclic, branched, or linear, completely fluorinated alkanes,
- b. cyclic, branched, or linear, completely fluorinated ethers with no unsaturations,
- c. cyclic, branched, or linear, completely fluorinated tertiary amines with no unsaturations, and
- d. sulfur containing perfluorocarbons with no unsaturations and with sulfur bonds only to carbon and fluorine.

Perfluorocarbon compounds shall be assumed to be absent from a product or process unless a manufacturer or facility operator identifies the specific individual compounds (from broad classes of these compounds) and the amounts present in the product or process, and provides an Environmental Protection Agency approved test method which can be used to quantify the specific compounds.

- 18. **propylene carbonate**
- 19. tertiary-butyl acetate; $C_6H_{12}O_2$ (1,1-dimethylethyl ester)

Tertiary-butyl acetate (also known as t-butyl acetate or tBAc) shall be considered exempt as a reactive organic compound only for purposes of reactive organic compound emissions limitations or reactive organic compound content requirements and will continue to be a reactive organic compound for purposes of all recordkeeping, emissions reporting, photochemical dispersion modeling, and inventory requirements which apply to reactive organic compounds.

- 20. CFC-11 (trichlorofluoromethane)
- 21. CFC-12 (dichlorodifluoromethane)
- 22. CFC-113 (1,1,2-trichloro-1,2,2-trifluoroethane)
- 23. CFC-114 (1,2-dichloro 1,1,2,2-tetrafluoroethane)
- 24. CFC-115 (chloropentafluoroethane)
- 25. HCFC-22 (chlorodifluoromethane)
- 26. **HCFC-31** (chlorofluoromethane)
- 27. HCFC-123 (1,1,1-trifluoro 2,2-dichloroethane)
- 28. HCFC-123a (1,2-dichloro-1,1,2-trifluoroethane)
- 29. HCFC-124 (2-chloro-1,1,1,2-tetrafluoroethane)
- 30. HCFC-141b (1,1-dichloro 1-fluoroethane)
- 31. HCFC-142b (1-chloro-1,1 difluoroethane)
- 32. HCFC-151a (1-chloro-1-fluoroethane)
- 33. HCFC-225ca (3,3-dichloro-1,1,1,2,2-pentafluoropropane)
- 34. HCFC-225cb (1,3-dichloro-1,1,2,2,3-pentafluoropropane)
- 35. **HFC-23** (trifluoromethane)
- 36. **HFC-32** (difluoromethane)
- 37. **HFC-43-10mee** (1,1,1,2,3,4,4,5,5,5-decafluoropentane)
- 38. HFC-125 (pentafluoroethane)
- 39. HFC-134 (1,1,2,2-tetrafluoroethane)
- 40. HFC-134a (1,1,1,2-tetrafluoroethane)
- 41. HFC-143a (1,1,1-trifluoroethane)
- 42. HFC-152a (1,1-difluoroethane)
- 43. **HFC-161 (ethylfluoride)**
- 44. **HFC-236ea** (1,1,1,2,3,3-hexafluoropropane)
- 45. **HFC-236fa** (1,1,1,3,3,3-hexafluoropropane)
- 46. **HFC-245ca** (1,1,2,2,3-pentafluoropropane)
- 47. **HFC-245ea** (1,1,2,3,3-pentafluoropropane)
- 48. **HFC-245eb** (1,1,1,2,3-pentafluoropropane)

- 49. **HFC-245fa** (1,1,1,3,3-pentafluoropropane)
- 50. **HFC-365mfc** (1,1,1,3,3-pentafluorobutane)
- 51. HFE-7100; (CF₃)₂CFCF₂OCH₃; (2-(difluoromethoxymethyl)-1,1,1,2,3,3,3-heptafluoropropane) or C₄F₉OCH₃; (1,1,1,2,2,3,3,4,4-nonafluoro-4-methoxy-butane)
- $\frac{52. \quad HFE-7200; (CF_3)_2CFCF_2OC_2H_5; (2-(ethoxydifluoromethyl)-1,1,2,3,3,3-heptafluoropropane)}{or C_4F_9OC_2H_5; (1-ethoxy-1,1,2,2,3,3,4,4,4-nonafluorobutane)}$

Rule 202.D.l0.l.1 requires an Authority to Construct and Permit to Operate when using more than one gallon per year per stationary source of any one of the following exempt compounds: dimethyl carbonate, methyl formate, HCFC-225ca, HCFC-225cb, HFC-43-10mee, HFC-245fa, HFC-365mfc, or HFE-7100 [(CF $_3$)2CFCF $_2$ OCH $_3$ or C $_4$ F $_9$ OC $_2$ H $_5$]. Rule 202.D.10.l.2 requires an Authority to Construct and Permit to Operate when using more than one gallon per year per stationary source of tertiary-butyl acetate. The one gallon per year per stationary source limit is a per compound limit for each compound in aggregate for the entire stationary source and includes any amounts of the compound used in mixed or diluted product.

[Link to Note No. 6]

1.	Acetone, ethane, methane, methyl acetate, and inorganic carbon compounds: carbon monoxide, carbon dioxide, carbonic acid, metallic carbides or carbonates, and ammonium carbonate
2.	— Chlorinated compounds
	1,1,1 trichloroethane (methyl chloroform)
	methylene chloride (dichloromethane)
	perchloroethylene (tetrachloroethylene)
3.	- Chlorofluorocarbons
	trichlorofluoromethane (CFC 11)
	dichlorodifluoromethane (CFC-12)
-	— chlorodifluoromethane (HCFC 22)
-	trifluoromethane (HFC 23)
	1,1,2 trichloro 1,2,2 trifluoroethane (CFC 113)
	1,2-dichloro-1,1,2,2-tetrafluoroethane (CFC-114)
	— chloropentafluoroethane (CFC 115)
4.	Hydrofluorocarbons
	pentafluoroethane (HFC 125)
	1,1,2,2-tetrafluoroethane (HFC-134)
-	1,1,1,2 tetrafluoroethane (HFC 134a)
-	1,1,1 trifluoroethane (HFC 143a)
	1,1 difluoroethane (HFC 152a)
5.	Hydrochlorofluorocarbons
	2,2 dichloro 1,1,1 trifluoroethane (HCFC 123)
	2 chloro 1,1,1,2 tetrafluoroethane (HCFC 124)
	1,1 dichloro 1 fluoroethane (HCFC 141b)
	1 chloro 1,1 difluoroethane (HCFC 142b)
6.	Parachlorobenzotrifluoride (PCBTF)
7.	Cyclic, branched or linear completely methylated siloxanes (VMS)

8.	Perflu	orocarbon compounds which fall into these classes:
	a.	Cyclic, branched, or linear, completely fluorinated alkanes;
	b.	Cyclic, branched, or linear, completely fluorinated ethers with no unsaturation;
	c.	Cyclic, branched, or linear, completely fluorinated tertiary amines with no unsaturations;
		and
	d.	Sulfur containing perfluorocarbons with no unsaturations and with sulfur bonds only to

$[\ldots]$

"Rotogravure Printing" means any printing process where the image area is etched or engraved relative to the surface of the image cylinder. Ink is transferred from minute etched wells on a plate cylinder to a substrate, which is supported by an impression roller, with excess ink removed by a doctor blade. The substrate is fed through the printing press in continuous rolls. [Link to Note No. 7]

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"Solvent" means any liquid containing any reactive organic compound or any toxic air contaminant, which is used as a diluent, thinner, dissolver, viscosity reducer, cleaning agent, drying agent, preservative, or other similar uses. [Link to Note No 8]

"Solvent Cleaning" means any activity, operation, or process (including, but not limited to, surface preparation, cleanup, or wipe cleaning) performed outside of a solvent cleaning machine, that uses solvent to remove uncured adhesives, uncured coatings, uncured inks, uncured polyester resin material, uncured sealant, or other contaminants, including, but not limited to, dirt, soil, oil, lubricants, coolants, moisture, fingerprints, and grease, from parts, products, tools, machinery, application equipment, and general work areas. Cleaning spray equipment used for the application of coating, adhesive, ink, polyester resin material, or sealant is also considered to be solvent cleaning irrespective of the spray material being cured. [Link to Note No. 9]

"Solvent Cleaning Machine" means any device or piece of equipment that uses solvent liquid or vapor to remove soils, moisture, or other contaminants from the surfaces of materials. Types of solvent cleaning machines include, but are not limited to, batch cold, batch vapor, in-line cold, in-line vapor, remote reservoir, and gas-path solvent cleaners, as defined in Rule 321. Buckets, pails, and beakers with capacities of 3.785 liters (1.00 gallon) or less are not considered solvent cleaning machines. However, the use of such a container or similar containers (e.g., hand-held spray bottles) with a solvent for cleaning is considered to be solvent cleaning. Any device or piece of equipment used exclusively for stripping shall not be considered to be a solvent cleaning machine. [Link to Note No. 10]

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"Stripping" means the use of solvent to remove materials such as cured adhesives, cured inks, cured sealants, cured or dried paints, cured or dried paint residues, or temporary protective coatings.

"Surface Preparation" means the removal of contaminants such as dust, soil, oil, grease, moisture, etc., prior to application of an adhesive, coating, ink, polyester resin material, or sealant. [Link to Note No. 11]

[...]

"Toxic Air Contaminant" means "Toxic air contaminant" as defined in Health and Safety Code Section 39655. [*Link to Note No. 12*]

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"Wipe Cleaning" means a solvent cleaning activity performed by hand rubbing an absorbent material such as a rag, paper, sponge, brush, or cotton swab containing solvent. [Link to Note No. 13]

[...]

NOTE No.	DEFINITION	NOTE	LINK TO RETURN TO PAR 102 ^a
1		The proposed new terms in Rule 102 appear in Rule 202 (Exemptions) and/or the proposed amended Rule (PAR) 321. In general, the District modeled the new definitions on those found in other California air districts or in federal law (40CFR, Part 63, Subpart T).	Click here.
2	Application Equipment	This term is in the proposed amended Rule 321 and it is found in several current rules. The definition is the same one used in the South Coast AQMD (SC) Rule 1171, except staff added "sealant" and "solvent" to be more general.	Click here.
3	Degreaser	Although the term "degreaser" is being eliminated in the PAR 321 (with one exception), inclusion of a "degreaser" definition in Rule 102 is intended to inform and clarify that a "degreaser" is a "solvent cleaning machine." (The PAR 321 definition of batch cleaning machine is the only place in the rule that the term "degreaser" appears.)	Click here.
4	Flexographic Printing	This definition should be in Rule 102 for rule clarity because the Rule 202.S.1 exemption uses this term.	Click here.
5	Organic Solvents and Photochemically Reactive Solvent	The District added the word "organic" for rule clarity.	Click here.
6	Reactive Organic Compound	The District is revising the <i>reactive organic compound</i> (ROC) definition by incorporating all of the 40 CFR, Part 51, Section 51.100(s) exempt compounds. The PAR 102 ROC definition includes a note on there being a permitting threshold in Rule 202.D.10.1.1 and 2 on some of the compounds. The provisions on assuming methylated siloxane and perfluorocarbon (PFC) compounds are absent from products stem from provisions in SJV Rule 1020, Section 3.53, definition of Volatile Organic Compounds. Unless a product manufacturer or facility operator identifies the methylated siloxane compounds or the PFC compounds in a product or process and an EPA approved test method to quantify the amounts the District will: 1. assume that there are no methylated siloxane compounds or PFC compounds that qualify as an exempt compound in a product or process, and	Click here.

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^a When using a computer to view this material, you may return to the PAR 102 text by clicking the 'here' link in the table using the left mouse button.

NOTE	DEFINITION	NOTE	LINK TO
No.			RETURN TO
			PAR 102 ^a
		2. treat the methylated siloxane and PFC	
		compounds as ROCs.	
7	Rotogravure Printing	This definition is the same one found in Rule	Click here.
		354. The Rule 202.S.1 exemption refers to this	
		type of process. Thus, for rule clarity, the	
8	Solvent	District is adding the definition to Rule 102. This new <i>solvent</i> definition is needed in Rule	Cli 1 1
0	Solvent	102 because the term is used in several newly	Click <u>here</u> .
		proposed Rule 102 definitions, the Rule 202.U	
		exemption, and many of the coating rules.	
		exemption, and many of the country rules.	
		The definition includes "any toxic air	
		contaminant' text, which is unique compared to	
		other air district solvent definitions. The	
		reasons that the District is including toxic air	
		contaminants (TACs) in this project are	
		discussed in Appendix I, Page I-5, (see	
		"Definition of Solvent Including Toxic Air	
		Contaminants (TACs)'). Click here to go to the	
		Appendix I, Page I-5, discussion.	
		It is not the APCD's intent to include TACs in	
		the "organic solvents" and the "photochemically	
		reactive solvent' definitions or modify the	
		meaning of those definitions through the	
		addition of the term 'solvent' to Rule 102.	
9	Solvent Cleaning	A clear delineation of what constitutes solvent	Click here.
		cleaning and use of a solvent cleaning machine	
		is needed to establish rule applicability and rule	
		requirements. The APCD modeled the <i>solvent</i>	
		cleaning definition on the organic solvent	
		cleaning definition used by the San Joaquin	
		Valley Unified Air Pollution Control District	
		(SJV) in their Rule 4663, Organic Solvent	
10	Solvent Cleaning Machine	Cleaning, Storage, and Disposal. This definition is modeled on the definition in	Click here.
10	Solvent Cleaning Machine	40 CFR §46.461. The APCD is making the	CHER HEIE.
		cutoff to be 1 gallon capacity instead of the two	
		gallons capacity in 40 CFR §46.461 because	
		existing Rule 321.B.2.a has a one gallon cutoff.	
		Also, the Ventura County APCD (VC) Rule	
		74.6.B.2.b has a one gallon cutoff whereas a	
		solvent cleaning machine must be used if the	
		solvent container is greater than one gallon.	
		The solvent cleaning machine definition is	
		needed in Rule 102 because the term is used in	
1.1	Confine Dung and	the "degreaser" and "solvent cleaning" definitions.	Clial Lan
11	Surface Preparation	This term and definition are modeled on	Click <u>here</u> .
		provisions from SC Rule 1171. The term will be used in the ROC limit tables in the rules	
		being modified to add new solvent cleaning	
		provisions. Staff added the term "moisture" in the	
		list of contaminants because the 40 CFR	
		or commission seems the 10 or 10	1

NOTE	DEFINITION	NOTE	LINK TO
No.			RETURN TO
			PAR 102 ^a
		§64.460 et seq. requirements for halogenated	
		solvent cleaning also include drying provisions.	
12	Toxic Air Contaminant	The District adding this definition at the request	Click here.
		of the regulated community. Appendix M	
		provides a list of the compounds that are	
		currently classified as a TAC. Click here to go	
		to Appendix M.	
13	Wipe Cleaning	This definition is the same one found in the SJV	Click here.
		Rule 4663.	

Click <u>here</u> to return to the list of Appendices in the Background Paper.



Appendix D Santa Barbara County Annotated Proposed Amended Rule 202, Exemptions to Rule 201

EXEMPTIONS TO RULE 201. (Adopted 10/18/1971, revised 5/1/1972 and 6/27/1977, readopted 10/23/1978, revised 12/7/1987, 1/11/1988, 1/17/1989, 7/10/1990, 7/30/1991, 11/05/1991, 3/10/1992, 5/10/1994, 6/28/1994, 4/17/1997, 3/17/2005, 1/17/2008, and [date of revised rule adoption])
al Provisions []
Temporary Equipment
[] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees. [Link to Note No. 1] a
Stationary Source Permit Exemption
[] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees.
Notwithstanding any exemption defined in this Rulerule, no new or modified stationary source that has the potential to emit air contaminants in excess of the amounts specified shall be exempt from permit requirements:
 k. 40 tons per year municipal waste combustor acid gases. In addition, notwithstanding any exemption defined in this rule, no stationary source that has the potential to emit any air contaminants in excess of the amounts specified shall be exempt from permit requirements: more than one gallon per year of any one of the exempt compounds listed below. The one gallon per year per stationary source limit is a per compound limit for each compound in aggregate for the entire stationary source and includes any amounts of the compound used in mixed or diluted product. a) dimethyl carbonate; or b) methyl formate; HCOOCH₃; or c) HCFC-225ca (3,3-dichloro-1,1,1,2,2-pentafluoropropane); or d) HCFC-225cb (1,3-dichloro-1,1,2,2,3-pentafluoropropane); or e) HFC-43-10mee (1,1,1,2,3,4,4,5,5,5-decafluoropentane); or f) HFC-245fa (1,1,1,3,3-pentafluoropropane); or g) HFC-365mfc (1,1,1,3,3-pentafluorobutane); or h) HFE-7100; (CF₃)₂CFCF₂OCH₃; (2-(difluoromethoxymethyl)-

1,1,1,2,3,3,3-heptafluoropropane); or

^a Notes concerning the proposed amended Rule 202 are within a table starting on Page D-5. When using a computer to view this material, use a link to get to a note by clicking the left-mouse button.

- i) HFE-7100; C₄F₉OCH₃; (1,1,1,2,2,3,3,4,4-nonafluoro-4-methoxy-butane); or
- 2. more than one gallon per year of tertiary-butyl acetate; $C_6H_{12}O_2$ (1,1-dimethylethyl ester). Tertiary-butyl acetate (also known as t-butyl acetate or tBAc) shall be considered exempt as a reactive organic compound only for purposes of reactive organic compound emissions limitations or reactive organic compound content requirements and will continue to be a reactive organic compound for purposes of all recordkeeping, emissions reporting, photochemical dispersion modeling, and inventory requirements which apply to reactive organic compounds. The one gallon per year per stationary source limit for tertiary-butyl acetate is an aggregate limit for the entire stationary source and includes any amounts of the compound used in mixed or diluted product.

[Link to Note No. 2]

[...]

E. Compliance with Rule Changes

[...]

If no application is filed within the ninety (90) day period, the application filing fee prescribed in Rule 210, Fees, shall be doubled and the equipment owner shall be subject to a Notice of Violation and to the penalty provisions set forth in California Health and Safety Code Sections 42400 et seq.

[...]

F. Internal Combustion Engines

[...]

- 5. [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees. [...]
- [...]
- 7. [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees. [...]
- 8. [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees. [...]

 $[\ldots]$

I. Coatings Applications Equipment and Operations

The following listed coating applications equipment and operations is are exempt from permit requirements. [. . .]

- 3. Equipment used in surface coating operations provided that the total amount of coatings and solvents used does not exceed 55 gallons per year. [...] Solvents meeting the criteria of Section U.2.b or Section U.2.c or that have a reactive organic compound content of 50 grams per liter or less, as determined by the Environmental Protection Agency Reference Method 24, do not contribute to the 55 gallons per year per stationary source limitation. [...] [Link to Note No. 3]
- 6. Unheated non-conveyorized coating dip tanks of 100 gallons or less capacity. [Link to Note No. 4]

[...]

K. Food Processing and Preparation Equipment

[...]

7. [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees.

 $[\ldots]$

P. Miscellaneous Equipment and Operations

[...]

14. [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees. [...]

 $[\ldots]$

U. Solvent Application Equipment and Operations

The following solvent <u>cleaning</u>, <u>application equipment solvent cleaning machines</u> and <u>their</u> operations is <u>are</u> exempt from permit requirements. Notwithstanding the listed exemptions, any collection of articles, machines, equipment or other contrivances within each listed equipment category at a stationary source that has aggregate emissions in excess of 10 tons per calendar year of any affected pollutant is not exempt.

- 1. Unheated solvent dispensing containers, unheated non-conveyorized Unheated nonconveyorized solvent rinsing containers or unheated non-conveyorized coating dip tanks of 1.00 gallons or less capacity provided that solvent cleaning performed in association with such containers complies with the requirements in Rule 321, Solvent Cleaning Machines and Solvent Cleaning.; this exemption shall not apply to degreasing equipment regulated under the provisions of Rule 321.

 [Link to Note No. 5]
- 2. Single pieces of degreasing equipmentsolvent cleaning machines, which use unheated solvent, and which:
 - a. have a liquid surface area (i.e., the area of the drain for remote reservoir cleaning machines or the solvent/air interface area for other solvent cleaning machines) of less than 929 square centimeters (1.0 square foot), unless the aggregate liquid surface area of all degreasers solvent cleaning machines at a stationary source, covered by this exemption is greater than 0.929 square meter (10 square feet), or [Link to Note No. 6]
 - b. use only organic solvents with an initial boiling point of 150 degrees Celsius (302 degrees Fahrenheit) or greater as determined by ASTM D-1078-8605, "Standard Test Method for Distillation Range of Volatile Organic Liquids," ASTM International, or
 - c. use <u>materials solvents</u> with a <u>volatile reactive</u> organic compound content of two percent or less by weight as determined by <u>EPA-Environmental Protection Agency</u> Method 24.
 - d. materials exempt pursuant to subsections b. and c. above do not contribute to the 0.929 square meter (10 square feet) limitation in subsection a. The liquid surface area of any solvent cleaning machine using the following solvent shall not be counted towards the 0.929 square meter (10 square feet) aggregate limit in subsection a. above:
 - any solvent that has a reactive organic compound content of 50 grams per liter or less, as determined by the Environmental Protection Agency Method 24, or

ii. any solvent exempt pursuant to subsection b. or subsection c. above.

[Link to Note No. 7]

3. Equipment used in wipe Wipe cleaning operations, provided that the solvents used do not exceed 55 gallons per year per stationary source and that the solvent cleaning complies with the requirements in Rule 321, Solvent Cleaning Machines and Solvent Cleaning. [Link to Note No. 8]

To qualify for this exemption, the owner or operator shall maintain records of the amount (gallons per year) of solvents used for wipe cleaning at the stationary source for each calendar year.

These records shall be maintained on site for at least 3 years and be made available to the District on request. Thereafter, the records shall be maintained either on site or readily available for expeditious inspection and review for an additional 2 years. Solvents meeting the criteria of 2.b. or c. above or that have a reactive organic compound content of 50 grams per liter or less, as determined by the Environmental Protection Agency Reference Method 24, do not contribute to the 55 gallons per year per stationary source limitation. [Link to Note No. 9]

- 4. Notwithstanding the Section U.3 exemption above, solvent cleaning to disinfect and decontaminate surfaces and equipment in hospitals, clinics, medical facilities, dentistry facilities, and other health care facilities, including but not limited to, sanatoriums, convalescent hospitals, convalescent homes, skilled nursing facilities, nursing homes, blood banks, and bloodmobiles. [Link to Note No. 10]
- 5. Notwithstanding the Section U.3 exemption above, solvent cleaning associated with janitorial cleaning, including graffiti removal. [Link to Note No. 11]

[...]

NOTE No.	SECTION IN RULE 202	PROPOSED AMENDED RULE (PAR) 202 NOTES	LINK TO RETURN TO PAR 202 ^a
1	D.5	Based on a comment from EPA, the District is adding the Rule 210 title 'Fees' in this section and all other sections where Rule 210 is referenced in Rule 202.	Click here.
2	D.10.1	The District is added provisions to allow some of the ROC definition's <i>exempt compound</i> usage rates to be up to one gallon per year per stationary source. Any usage rate above this threshold will negate any otherwise applicable permit exemptions. The ARB has not recommended that air districts designate these compounds as <i>exempt compounds</i> (i.e., non-ROC) due to health risk and/or CEQA implications. The genesis for the usage rate threshold stems from provisions in the SJV Rule 1020 definition of "Volatile Organic Compound."	Click here.
		compound in PAR 102 mentions that Rule 202.D.10.1,1 and 2 provisions apply when using certain compounds in excess of the threshold.	
3	I.3	The new text is proposed to make the solvent exemption component of Section I.3 consistent with the proposed revised Section U.3 provisions.	Click <u>here</u> .
4	I.6	This exemption is currently located in Rule 202, Section U.1. The District is moving the coating dip tank exemption to Section I because Section I is for coating applications.	Click <u>here</u> .
5	U.1	The District is deleting the <i>unheated solvent dispensing containers</i> exemption text from this section. Rule 202 Section V, Storage and Transfer Equipment and Operations, Sections V.1 and/or V.4 provide exemptions for such solvent storage containers and transfer equipment.	Click here.
		On the exemption for unheated nonconveyorized solvent rinsing containers, the District is changing the exemption applicability threshold from 100 gallons capacity to one gallon capacity. This provides consistency with the definitions of <i>solvent cleaning</i> and <i>solvent cleaning machines</i> and the proposed revised Rule 321 provisions.	
		The 'unheated non-conveyorized coating dip tank' exemption text is being relocated to 202.I.6 because the provision relates to coating applications.	
6	U.2.a	Per a request from the regulated community, the District added text to clarify the meaning of fiquid surface area in PAR 202.U.2.a. The added text is consistent with the Rule 321 definition of the "solvent/air interface area."	Click here.

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^a When using a computer to view this material, you may return to the PAR 102 text by clicking the 'here' link in the table using the left mouse button.

NOTE	SECTION IN	PROPOSED AMENDED RULE (PAR) 202 NOTES	LINK TO
No.	RULE 202	, ,	RETURN TO
			PAR 202 ^a
7	U.2.d	The District revised Rule 202.U.2.d for improved rule clarity and to	Click <u>here</u> .
		include the 50 grams per liter or less surface area exclusion. The	
		regulated community requested that SCMs employing solvents with	
		an ROC of 50 g/l or less not be counted when determining the Rule	
		202, Section U.2.a aggregate liquid surface area figure. Consistent	
		with this request, the District is including such a provision in PAR	
		202.U.2.d.i. PAR 202.U.d.ii carries forward an existing rule	
		provision on what to exclude when performing the aggregate liquid	
		surface area assessment for Rule 202.U.2.a.	~
8	U.3	Rule 321 provisions apply regardless of the operation being permit	Click <u>here</u> .
		exempt. One of the major changes to Rule 321 is that the wipe	
		exemption is being removed from Rule 321. Thus, facilities	
		performing wipe cleaning not otherwise exempt from Rule 321 will	
		need to comply with the requirements (e.g., the Section D, good	
		housekeeping practices). For rule clarity, the APCD is adding text,	
		which makes Rule 202.U.3 applicable only for sources using 55	
		gallons per year of solvent for wipe cleaning and that comply with	
		Rule 321.	
		Sources subject to the Rule 202.U.3 exemption will also be eligible	
		for the Rule 321.B.15 exemption. This is a partial Rule 321	
		exemption and will allow the use of solvents that do not comply with	
		the Section M.1 solvent requirements (Table 1 ROC limits). Any	
		person claiming the Rule 321.B.15 exemption will need to keep	
		monthly and calendar year total records per the provisions in Rule	
		321 Section R.2.	
9	U.3	The APCD added the exclusionary text for solvent cleaning with low-	Click here.
		ROC solvents to clarify that such operations do not require a permit	
		regardless of the usage rate. The regulated community requested that	
		the District provide provisions to recognize the use of such solvents	
		and to avoid triggering permit requirements when there is an	
		increased aqueous solvent usage rate. In general, the ratio of	
		replacement aqueous solvent usage to petroleum solvent usage is 1.5	
		to 1.	
10	U.4	The District is adding this exemption for rule clarity based on	Click here.
		requests from industry.	
11	U.5	Same as above.	Click <u>here</u> .

Click <u>here</u> to return to the list of Appendices in the Background Paper.

Appendix E Santa Barbara County Summary of Significant Changes to Rule 321, Solvent Cleaning Machines and Solvent Cleaning

Solvent ROC Content Limits

The proposed amended Rule (PAR) 321, Sections H.7, I.7, K.6, and M.1 will limit the solvent ROC content. Solvents used in the following devices and processes shall be limited to 50 grams per liter of material:

- 1. Remote reservoir cold cleaning machines.
- 2. Batch and in-line cold cleaning machines.
- 3. General product cleaning and surface preparation for coating application.
- 4. General repair cleaning and maintenance cleaning.

PAR 321.M.1 includes solvent ROC content limits higher than the 50 grams per liter limit for specific solvent cleaning categories:

Grams/Liter Solvent Cleaning Category

- (a) Product Cleaning During Manufacturing Processes and Surface Preparation for Coating Application:
- 900 1) Electrical Apparatus Components & Electronic Components
 - 2) Medical Devices & Pharmaceuticals
 - 3) Silicone Manufacturing
 - **(b)** Repair Cleaning and Maintenance Cleaning:
- 900 1) Electrical Apparatus Components & Electronic Components
 - Medical Devices & Pharmaceuticals (tools, equipment, machinery, and general work surfaces)
 - 3) Silicone Manufacturing
- 950 (c) Cleaning of Coatings Application Equipment

(d) Cleaning of the Following Items and Equipment and their Components: 1)
Aerospace Vehicles; 2) Aerospace
Vehicle Payloads and Satellites; 3)
Aerospace Vehicle, Aerospace Vehicle
Payload, and Satellite: a) Transport
Equipment (e.g., railcars, trucks, trailers, forklifts, and containers), and b) Support
Processing Equipment (e.g., clean rooms, tools, payload fairing fixtures, alignment jigs, fuel and oxidizer loading carts and associated transfer lines).

Other Rule 321 Revisions

321.A – APPLICABILITY. The revised rule is being expanded to include solvent cleaning (e.g., wipe cleaning, spray gun cleaning).

321.B – EXEMPTIONS. The significant exemption changes in PAR 321 are itemized in the following.

- Revision of the 321.B.1 text to indicate that the
 two percent or less threshold is for a solven's
 reactive organic compound and toxic air
 contaminant content. If either one is exceeded,
 then the exemption does not apply. Also,
 recordkeeping provisions are added to facilitate
 verification of exemption claims.
- 2. Deletion of the Section B.2 exemption (solvent cleaners having one gallon capacity or one square foot) because the revised Rule 321 provisions will apply to these small containers. The use of containers that are one gallon or less in a degreasing operation is categorized as *solvent cleaning* (see PAR 102 definition of *solvent cleaning machine*). And remote reservoirs previously exempt by the one square foot provision need to comply with the revised rule requirements (e.g., use of a solvent with an ROC content of 50 g/l or less).
- 3. Deletion of the exemptions for wipe cleaning, spray gun cleaning, and enclosed small cold cleaners (current Rule 321.B.4.a, 321.B.4.d, and 321.B.4.f). The PAR 321 includes provisions that are applicable to these processes and devices.
- Addition of several exemptions that are similar to those found in the San Joaquin Valley Unified APCD, the South Coast AQMD, and the Ventura County APCD solvent rules.
- 321.C DEFINITIONS. The APCD proposes new and revised definitions to provide clarity to the rule exemptions and rule requirements. Appendix F (annotated PAR 321) provides information on many of the new definitions in Rule 321.

900

321.D – GENERAL OPERATING REQUIREMENTS. Most of the changes to these provisions clarify good housekeeping and maintenance requirements.

321.E, J, AND L – VAPOR CLEANING MACHINE REQUIREMENTS. For vapor cleaning machines, the PAR 321 provisions require several new and revised requirements related to solvent pumps, heating controls, air blankets, safety devices, and other emission reduction techniques:

- The proper use of superheated vapor zones (E.9),
- Idling and downtime mode covers (J.2 & L.3),
- The condenser flow switch is to automatically shut off the sump heat if the condenser coolant stops circulating or becomes warmer that its designed operating temperature (J.4 & L.5),
- Clarification that the vapor level control device is to automatically shut off the sump heat if the vapor level rises above the height of the primary condenser (J.5 & L.6),
- For units with solvent flow, clarification that a device (e.g., a spray pump control switch) is required to prevent the solvent flow pump operation unless the solvent vapor level is at the designed operating level (J.6 & L.7),
- A device that automatically turns off the sump heat if the sump heater coils are not submerged in the liquid solvent (J.7 & L.8), and
- The following provisions (effective one year after the rule revision):
 - A freeboard ratio of 1.0 (J.8 & L.9),
 - For a batch vapor cleaning machine, an automatic parts handling system (J.11.a),^a
 - Circumferential trough and water separator (J.11.b, J.11.c, L.11.a, & L.11.b), and
 - A freeboard refrigeration device and a superheated vapor zone that meet the rule requirements (J.11.d, J.11.e, L.11.c, & L.11.d).^a

321.M – SOLVENT CLEANING. This is an entirely new section. In addition to limiting the solvent ROC content (as discussed on page E-1):

- Section M.2 specifies appropriate cleaning devices and methods.
- Section M.3 requires the use of an enclosed system (or equivalent) when cleaning spray application equipment.^a

321.N - EMISSION CONTROL SYSTEM

REQUIREMENTS. The two significant changes in this section are the addition of Sections N.5 & N.6. Section N.5 establishes a deadline for performing an initial source test on the emission control system. And, Section N.6 requires that emissions from an emission control system not be in excess of the emissions otherwise expected when complying with the solvent ROC-limits.

321.O – ALTERNATIVE OPERATING AND EQUIPMENT REQUIREMENTS FOR AN AIRLESS OR AIR-TIGHT SOLVENT CLEANING MACHINE. Air-tight and airless cleaning systems are state-of-the-art machines that have extremely low emissions. Allowing use of such systems in lieu of meeting other rule provisions is consistent with how the SJV and SC rules are written.

321.R – RECORDKEEPING REQUIREMENTS. The revised recordkeeping provisions:

- Are being expanded to apply to all solvent cleaning machines and solvent cleaning (irrespective of such operations or equipment being subject to permits).
- Require monthly records on the assessment of the amount of solvents used and their respective ROC content
- For solvent cleaning, require records on the type of cleaning activity, by cleaning categories listed in Table 1.
- For solvent cleaning machines, require records on the type of solvent cleaning machine, type solvent, ROC content, and solvent's initial boiling point.
- For an emission control system, require daily records on the key operating parameters.
- For Sections B.9 or B.15 exemption claims, require that appropriate records on the solvent usage be maintained.
- Eliminate the existing Section P.2 recordkeeping provision for the "small surface area" exemption (current Section B.2.b), which is proposed for deletion.

321.S – REPORTING. The reporting requirements are being expanded to include solvent cleaning subject to a Permit, monthly/annual solvent usage data, PTO #, and name and address of Permit holder.

321.T – COMPLIANCE SCHEDULE. New solvent cleaning operations and new solvent cleaning machines are to comply with the Rule 321 requirements the first time they are performed/operated in the District.

Rule 102, Rule 202, and/or Rule 321 revisions will result in:

^aApplicable when using a solvent with an ROC content in excess of 50 grams per liter.

- Existing qualifying solvent cleaning operations becoming subject to Rule 321 for the first time, and
- Some existing solvent cleaning machines becoming subject to Rule 321 for the first time.

In such cases, Section T provides the owners/operators one month to comply with the applicable operating requirements, six months to comply with the applicable recordkeeping and reporting requirements, and one year to comply with

the equipment requirements and the solvent ROC limits.

Table 1 summarizes provisions in Sections H.7, I.7, J.8, J.11, K.6, L.9, L.11, and M that will have an effective date one year after the adoption of the revised rules. Table 2 provides a quick-reference list of significant new and revised requirements in proposed amended Rule 321. Table 3 shows the effective dates for the new and revised Rule 321 requirements.

Table 1. REQUIREMENTS THAT BECOME EFFECTIVE ONE YEAR FROM THE DATE OF ADOPTION OF THE REVISED RULE 321, SOLVENT CLEANING MACHINES AND SOLVENT CLEANING

SECTION	PROVISION
H.7	Solvents used in remote reservoir cold cleaning machines shall have an ROC content of 50 grams per
	liter or less (unless exempt by Section B.8).
I.7	Solvents used in batch cold cleaning machines shall have an ROC content of 50 grams per liter or less
	(unless exempt by Section B.8).
J.8	The freeboard ratio for batch vapor cleaning machines shall be 1.0 or greater.
J.11	Batch vapor cleaning machines using solvents with an ROC content in excess of 50 g/l shall be
	equipped with all of the following (unless exempt by Sections B.18 or B.20):
	a. An automated parts handling system;
	b. A circumferential trough;
	c. A water separator (not required for solvents that form azeotropes with water);
	d. A freeboard refrigeration device that is operated such that the chilled air blanket temperature,
	measured at the center of the air blanket, is no greater than 40 percent of the initial boiling point of
	the solvent, in degrees Fahrenheit, for solvents that do not form azeotropes with water, or 50 percent
	of the initial boiling point, in degrees Fahrenheit, for solvents that form azeotropes with water; and
	e. A superheated vapor zone where parts remain in the vapor zone for at least the minimum dwell time,
	as specified by the manufacturer. The temperature within the superheated vapor zone shall be at
K.6	least 10 degrees Fahrenheit above the initial boiling point of the solvent being used.
	Solvents used in in-line cold cleaning machines shall have an ROC content of 50 grams per liter or less (unless exempt by Section B.8).
L.9	The freeboard ratio for in-line vapor cleaning machines shall be 1.0 or greater. (An alternative that
	complies with L.10 may be used.)
L.11	In-line vapor cleaning machines using solvents with an ROC content of 50 g/l or greater shall be equipped with all of the following:
	equipped with all of the following.
	a. An automated parts handling system;
	b. A circumferential trough;
	c. A water separator (not required for solvents that form azeotropes with water);
	d. A freeboard refrigeration device that is operated such that the chilled air blanket temperature,
	measured at the center of the air blanket, is no greater than 40 percent of the initial boiling point of
	the solvent, in degrees Fahrenheit, for solvents that do not form azeotropes with water, or 50 percent
	of the initial boiling point, in degrees Fahrenheit, for solvents that form azeotropes with water; and
	e. A superheated vapor zone where parts remain in the vapor zone for at least the minimum dwell time,
	as specified by the manufacturer. The temperature within the superheated vapor zone shall be at
	least 10 degrees Fahrenheit above the initial boiling point of the solvent being used.

SECTION	PROVISION
M.1	Except as provided in Section N, no person shall use a solvent to perform solvent cleaning which exceeds the ROC content limit specified in Table 1 (unless exempt by Sections B.8, B.9, B.10, B.15, or B.16).
M.2	Any person performing solvent cleaning shall use one or more of the devices or methods specified in M.2.
M.3	Any person performing solvent cleaning of application equipment shall use a cleaning material that has an ROC content of 50 grams/liter or less or shall use an enclosed cleaning system.

Note: Although effective upon adoption of the revised rule, the Section N.5 requirement to perform an initial source test on an emission control system has a one-year deadline (or later deadline as established by an Authority to Construct).

Table 2. QUICK-REFERENCE LIST OF SIGNIFICANT NEW AND REVISED REQUIREMENTS IN PROPOSED AMENDED RULE 321

SECTION(S)	AFFECTED EQUIPMENT OR SOLVENT CLEANING CATEGORIES	REQUIREMENT
H.7, I.7, K.6, & M.1	Cold Solvent Cleaning Machines: Remote Reservoir, Batch, and In-Line Some Solvent Cleaning Categories as Specified in the Section M.1, Table 1	Solvent limit of 50 grams of ROC per liter
M.1	Some Solvent Cleaning Categories as Specified in the Section M.1, Table 1	Solvent limit of 900 or 950 grams of ROC per liter
J.8 & L.9	Vapor Cleaning Machines (Batch & In-Line)	Freeboard Ratio of 1.0 or Greater
J.4–J.7 & L.5–L.8	Vapor Cleaning Machines (Batch & In-Line)	 Spray Pump Control Switch and Automatic Sump Heat Shut Off for: Condenser Flow Too Hot or Not Circulating, Vapor Level Too High, and Sump Heater Coils Not Being Submerged in the Liquid Solvent
J.11 & L.11	Vapor Cleaning Machines (Batch & In-Line) that use Solvents with an ROC Content in Excess of 50 Grams per Liter	 Automatic Parts Handling System,^a Circumferential Troughs, Water Separators, Freeboard Refrigeration Device, and Superheated Vapor Zone
M.2	Cleaning Devices and Methods	Sanctioned cleaning methods and devices (e.g., wipe cleaning; hand-held spray bottles; solvent flow, dip, or flush methods) used in acceptable ways
M.3	Solvent Cleaning of Spray Application Equipment	The cleaning material is to contain ≤ 50 grams of ROC/liter. Alternatively, if a solvent with a higher ROC content is employed, the process shall use an enclosed system (or an APCO-approved alternative)

^a The requirement to install an automatic parts handling system probably does not apply to an in-line vapor cleaning machine as such a unit is already so equipped.

Table 3. EFFECTIVE DATES FOR THE NEW AND REVISED RULE 321 REQUIREMENTS^a

	Solvent limit of 50 Grams of ROC per Liter (H.7, I.7, K.6 & M.1)	Solvent limit of 900 or 950 Grams of ROC per Liter (B.2, B.8, & M.1)	Solvent with > 2% (by Wt.) ROC or TAC Content are not exempt (B.1)	Exemption Claims to be Supported with Records (B.1, B.9, B.15, & B.18)	General Operating Requirements (D)	Use of Idling & Downtime Mode Covers for Vapor Cleaning Machines (E.1, J.2, & L.3)	Allow the Solvent Vapor Layer to Collapse Before Turning Off the Primary Condenser (E.3)	Proper Use of Superheated Vapor Zones (E.9)	Gas-Path Cleaners with a Solvent > 50 g/l, Spent Solvent is to be Collected (G.3)	Rolling Motion Only (No Splashing) When Using a Pump-Agitated Bath (G.5)	Use of a Downtime Mode Covers for Cold Cleaning Machines (I.1 & K.3)	Vapor Cleaning Machine Control Switches & Safety Devices $(J.4-J.7 \& L.5-L.8)^b$	Freeboard Ratio of 1.0 or Greater on Vapor Cleaning Mach's (J.8 & L.9)	Minimize Passages on In-Line Cleaning Machines (K.2 & L.2)	Enhanced Vapor Cleaning Machine Controls (J.11 & L.11) ^c	Cleaning Devices & Methods (M.2)	Solvent Cleaning of Application Equipment (M.3)	Emission Control Device Initial Test & Potential Emission Cap (N.5 & 6)	Airless & Air-Tight Solvent Cleaning Machines (O)	Monthly Recordkeeping & Annual Reporting (R & S)
EFFECTIVE																				
Upon Adoption ^d			X	X	X	X	X	X	X	X	X	X		X				X	X	X
One Year After Adoption	X	X											X		X	X	X			
EQUIPMENT IMPACTED																				
Aerosol Products Subject to PAR 321.B.9				X																
Wipe Cleaning Subject to PAR 321.B.15				X																
Batch Vapor Solvent Cleaning Machines Subject to PAR 321.B.18				X																
Batch Cold Cleaning Machines	X	X	X		X					X	X ^e							X		X

^a This table is intended to summarize many of the proposed new and revised Rule 321 requirements with effective dates or compliance schedule data. If there is a conflict between data shown in Table 3 and the proposed amended Rule 321 or an omission, the proposed amended Rule 321 text takes precedence.

^b Includes spray pump control switch and automatic sump heat shut off for 1) condenser flow too hot or not circulating, 2) vapor level too high, and 3) sump heater coils not being submerged in the liquid solvent.

^c Enhanced vapor solvent cleaning controls require use of an automated parts handling system, circumferential trough, water separator, freeboard refrigeration device, and superheated vapor zone. These enhanced controls are required when the solvent contains in excess of 50 grams per liter. An exemption in Section B may apply to these requirements.

d Rule 321.T, Compliance Schedule, provides compliance periods for existing solvent cleaning operations and existing solvent cleaning machines that become subject to Rule 321 due to a Rule 102, Rule 202, and/or Rule 321 revision. In general, the owners/operators of such equipment will have one month to comply with the applicable operating requirements, six months to comply with the applicable recordkeeping and reporting requirements, and one year to comply with the equipment requirements and the solvent limits in Table 1. New solvent cleaning operations and new solvent cleaning machines are to comply with the Rule 321 requirements the first time they are performed/operated in the District.

^e Required when using a high volatility solvent.

	Solvent limit of 50 Grams of ROC per Liter (H.7, I.7, K.6 & M.1)	Solvent limit of 900 or 950 Grams of ROC per Liter (B.2, B.8, & M.1)	Solvent with > 2% (by Wt.) ROC or TAC Content are not exempt (B.1)	Exemption Claims to be Supported with Records (B.1, B.9, B.15, & B.18)	General Operating Requirements (D)	Use of Idling & Downtime Mode Covers for Vapor Cleaning Machines (E.1, J.2, & L.3)	Allow the Solvent Vapor Layer to Collapse Before Tuming Off the Primary Condenser (E.3)	Proper Use of Superheated Vapor Zones (E.9)	Gas-Path Cleaners with a Solvent > 50 g/l, Spent Solvent is to be Collected (G.3)	Rolling Motion Only (No Splashing) When Using a Pump-Agitated Bath (G.5)	Use of a Downtime Mode Covers for Cold Cleaning Machines (I.1 & K.3)	Vapor Cleaning Machine Control Switches & Safety Devices (J.4 – J.7 & L.5 – L.8) ^b	Freeboard Ratio of 1.0 or Greater on Vapor Cleaning Mach's (J.8 & L.9)	Minimize Passages on In-Line Cleaning Machines (K.2 & L.2)	Enhanced Vapor Cleaning Machine Controls (J.11 & L.11) ^c	Cleaning Devices & Methods (M.2)	Solvent Cleaning of Application Equipment (M.3)	Emission Control Device Initial Test & Potential Emission Cap (N.5 & 6)	Airless & Air-Tight Solvent Cleaning Machines (O)	Monthly Recordkeeping & Annual Reporting (R & S)
EFFECTIVE																				
Upon Adoption ^d			X	X	X	X	X	X	X	X	X	X		X				X	X	X
One Year After Adoption	X	X											X		X	X	X			
EQUIPMENT IMPACTED																				
In-Line Cold Cleaning Machines	X	X	X		X					X	X			X				X		X
Batch Vapor and In-Line Vapor Cleaning Machines			X		X	X	X	X		X		X	X	X^f	X			X		X
Remote Reservoir Cleaning Machines	X	X	X		X													X		X
Gas-Path Solvent Cleaners			X		X				X											X
Solvent Cleaning (Performed Outside of a Solvent Cleaning Machine)	X	X	X		X											X	X	X		X
Airless Solvent Cleaners and Air-Tight Solvent Cleaners			X		X														X	X

Footnotes a – e appear on the previous page.

Click $\underline{\text{here}}$ to return to the list of Appendices in the Background Paper.

^f Applicable to in-line vapor cleaning machines (not batch vapor cleaning machines).

Appendix F Santa Barbara County Annotated Proposed Amended Rule 321, Solvent Cleaning Machines and Solvent Cleaning

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RULE 321. SOLVENT CLEANING <u>MACHINES OPERATIONS AND SOLVENT CLEANING</u>. (Adopted 2/24/1975, readopted 10/23/1978, revised 6/11/1979, 7/10/1990, 4/17/1997, 7/17/1997, and [date of revised rule adoption]) [Link to Note No. 1] a

A. Applicability

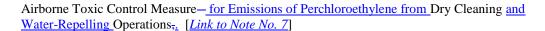
This Rule_rule shall apply to any person who owns, operates, or uses any solvent cleaning machine or performs any solvent cleaning operation outside of a solvent cleaning machine operations during the production, repair, maintenance, or servicing of parts, products, tools, machinery, equipment, or in general work areas at any stationary source. [Link to Note No. 2]

B. Exemptions

Except as otherwise specifically provided herein, the provisions of this rule shall not apply to the following:

- 1. <u>Any Ssolvent cleaning machine equipped with and any solvent cleaning performed with operations using a solvent (including emulsions) that contains two percent by weight or less of each of the following:</u>
 - <u>a.</u> <u>#R</u>eactive organic compounds <u>by weight</u> (as determined by <u>EPA-Environmental</u> <u>Protection Agency method 24), and</u>
 - b. Toxic air contaminants (as determined by generic solvent data, solvent manufacturer's composition data or by a gas chromatography test and a mass spectrometry test). shall not be subject to the requirements of this Rule. [Link to Note No. 3]
 - Any person claiming this exemption shall maintain the records specified in Sections
 R.1.a.1) and R.1.a.2) in a manner consistent with Section R.3 and make them available for review.
- 2. Except for the Rule 321 Section G.2 requirement that the cleaner be covered when work is not being processed (use of covers are not required for remote reservoir cold cleaners using low volatility solvents), the provisions of this Rule shall not apply to an unheated solvent cleaner that:
 - a. has a capacity of 3.785 liters (1 gallon) or less, or
 - b. has an evaporative surface area of less than 929 square centimeters (1 square foot). However, if the aggregate evaporative surface area of all such solvent cleaners at a stationary source is greater than 0.929 square meters (10 square feet), none of the cleaners are exempt. [Link to Note No. 4]
- 32. The provisions of Rule 321 Section J.7 shall not apply to open top vapor solvent cleaners with less than 1 square meter (10.8 square feet) of evaporative surface area. The cleaning of architectural coating application equipment provided that the solvent used does not exceed 950 grams of reactive organic compound per liter of material. [Link to Note No. 5]
- 4. The provisions of this Rule shall not apply to:
 - a. wipe cleaning, [Link to Note No. 6]
- <u>3.b.</u> <u>dD</u>ry cleaning operations of clothing or other fabrics covered under Rule 320, Petroleum Solvent Dry Cleaners, or <u>17-California Code</u> of Regulations <u>Title 17</u>, Section 93109, <u>Perchloroethylene</u>

^a Notes concerning the proposed new and revised Rule 321 provisions are within a table starting on Page F-29. When using a computer to view this material, use a link to get to a note by clicking the left-mouse button over the *'Link to Note No*," text.



- 4. e. sStripping of cured coatings (e.g., stripping), cured adhesives, (e.g., debonding, unglueing) cured sealants, and cured inks, except the stripping of such materials from spray application equipment. [Link to Note No. 8]
 - d. spray gun cleaning operations, [Link to Note No. 9]
- solvent cleaning machines that uses any halogenated hazardous air pollutant solvent centaining methylene chloride, perchloroethylene, trichloroethylene, 1,1,1 trichloroethane, carbon tetrachloride, or chloroform, or any combination of these halogenated hazardous air pollutants solvents, in a total concentration greater than 5 percent by weight, as a cleaning and/or drying agent, provided such a solvent cleaning machines are is subject to 40 CFR, Part 63, Subpart T, National Emission Standards for Hazardous Air Pollutants: Halogenated Solvent Cleaning, (Sections 63,460 et. seq.) or.
 - f. cold solvent degreasers of 37.854 liters (10 gallons) or less in capacity, provided the degreasers are designed to operate in a closed system fashion (i.e., sealed when operated) and agitated through pump recirculation, mechanical mixing (a mixer), or with ultrasonics. Gas or air agitation shall not be used. [Link to Note No. 12]
- 6. Any equipment or operation that is subject to or specifically exempted by any of the following District rules.
 - a. Rule 325, Crude Oil Production and Separation.
 - b. Rule 326, Storage of Reactive Organic Compound Liquids.
 - c. Rule 330, Surface Coating of Metal Parts and Products.
 - d. Rule 337, Surface Coating of Aircraft or Aerospace Vehicle Parts and Products.
 - e. Rule 339, Motor Vehicle and Mobile Equipment Coating Operations.
 - f. Rule 343, Petroleum Storage Tank Degassing.
 - g. Rule 344, Petroleum Sumps, Pits and Well Cellars.
 - h. Rule 349, Polyester Resin Operations.
 - i. Rule 351, Surface Coating of Wood Products.
 - j. Rule 353, Adhesives and Sealants.
 - k. Rule 354, Graphic Arts. [Link to Note No. 13]
- 7. Janitorial cleaning, including graffiti removal. [Link to Note No. 14]

- 8. Provisions of Sections H.7, I.7, K.6, and, M.1 shall not apply to the following:
 - a. Cleaning of solar cells, laser hardware, scientific instruments, high-precision optics,
 telescopes, microscopes, avionic equipment, and aerospace and military fluid systems;
 and

[*Link to Note No. 15*]

- Cleaning in laboratory tests and analyses, including quality assurance and quality control
 applications, bench scale projects, or short-term (less than 2 years) research and
 development projects; and
- Cleaning of cotton swabs to remove cottonseed oil before cleaning of high-precision optics.
- d. In addition, the provisions of Sections H.7, I.7, and K.6 shall not apply to solvent cleaning machines employed with solvents having 900 grams of reactive organic compound per liter of material or less during the production, repair, maintenance, or servicing of electrical apparatus components, electronic components, satellites, satellite components, aerospace vehicles, aerospace vehicle components, aerospace vehicle payloads, aerospace vehicle payload components, medical devices, or silicone manufacturing. [Link to Note No. 16]
- 9. Solvent cleaning with aerosol products shall not be subject to Section D.9 and Section M.1 provisions and the Section M.2.c prohibition on solvent atomization provided:
 - a. 160 fluid ounces or less of aerosol products are used per day, per facility, and
 - b. Records are maintained as specified in Sections R.2 and R.3, and
 - c. The aerosol products comply with volatile organic compound limits for consumer products specified in the California Code of Regulations, Title 17, Section 94507 et seq. [Link to Note No. 17]
- 10. Provisions of Section M.1, Table 1, Solvent Cleaning Activity (c) shall not apply to the cleaning of application equipment when such equipment is used to apply a coating on a satellite or when applying a radiation-effect coating. [Link to Note No. 18]
- 11. Section D.9 and M.2.c prohibitions on solvent atomization shall not apply to the following applications:
 - a. Cleaning of the nozzle tips of automated spray equipment systems, except for robotic systems.
 - b. Cleaning with hand-held spray bottles, squirt bottles, and other closed containers having a capacity of one liter or less.
 - c. Cleaning of gas turbines or jet engines using a gas-path solvent cleaner. [Link to Note No. 19]
- 12. De-icing of aircraft and aerospace vehicles. [Link to Note No. 20]
- 13. Solvent cleaning with a solvent containing 50 grams of reactive organic compounds per liter of material or less shall not be subject to the Section D.9 provision. [Link to Note No. 21]
- 14. Solvent cleaning to disinfect and decontaminate surfaces and equipment in hospitals, clinics, medical facilities, dental care facilities, and other health care facilities, including but not limited

- to, sanatoriums, convalescent hospitals, convalescent homes, skilled nursing facilities, nursing homes, blood banks, and bloodmobiles. [Link to Note No. 22]
- 15. Provisions of Section M.1 shall not apply if the net aggregate amount of solvent used for all solvent cleaning subject to Rule 321 (i.e., subject to Sections D, M.2, and/or M.3 provisions) at a stationary source does not exceed 55 gallons per year. Solvents with a reactive organic compound content of 50 grams per liter of material or less do not count towards the 55 gallons per year aggregate limit. Any person claiming this exemption shall maintain records as specified in Sections R.2 and R.3. [Link to Note No. 23]
- 16. Provisions of Section M.1 shall not apply to the following applications:
 - a. Cleaning of ultraviolet lamps used to cure ultraviolet inks coatings, adhesives, or resins.
 - b. Cleaning of mold release compounds from molds.
 - Cleaning of aerospace assembly and subassembly surfaces that are exposed to strong
 oxidizers or reducers such as nitrogen tetroxide, liquid oxygen, or hydrazine.
 - d. Cleaning of paper gaskets.
 - e. Cleaning of clutch assemblies where rubber is bonded to metal by means of an adhesive.
 - Cleaning of hydraulic actuating fluid from filters and filter housings. [Link to Note No. 24]
 - g. Wipe cleaning to remove crude oil and crude oil residue from well workover, drilling operations, and other activities related to petroleum production and processing on offshore platforms, provided the solvent reactive organic compound content does not exceed 800 grams per liter of material and the reactive organic compound composite partial pressure is no more than 8 millimeters of mercury at 20 degrees Celsius. [Link to Note No. 25]
- 17. Provisions of Sections H.7, I.7, and K.6 shall not apply to the following applications, provided the solvent reactive organic compound content does not exceed 900 grams per liter of material and the reactive organic compound composite partial pressure is no more than 5 millimeters of mercury at 20 degrees Celsius:
 - a. Cleaning associated with the manufacturing of nuts and bolts designed for automotive racing applications.
 - b. Cleaning of precision-lapped mechanical seals in pumps that handle liquefied gasses.

 [Link to Note No. 26]
- 18. Provisions of Sections J.11.a, d, and e shall not apply to batch vapor cleaning machines with a solvent/air interface area less than 929 square centimeters (1 square foot) or a solvent capacity less than 2 gallons, provided all such solvent cleaning machines emit, in aggregate, less than 55 pounds of reactive organic compounds per month per stationary source. Any person claiming this exemption shall maintain records as specified in Sections R.1 and R.3. [Link to Note No. 27]
- 19. The use of solvent for purposes other than cleaning. [Link to Note No. 28]
- 20. The Section E.7 and Section J.11.a, d, and e provisions shall not apply to batch vapor cleaning machines provided:
 - a. The equipment was installed before January 1, 2007; and

- b. The solvent/air interface area is less than 4.40 square feet or the solvent capacity is less than 2 gallons; and
- c. The equipment is used only for cleaning electronic components; and
- d. The total aggregate reactive organic compound emissions from all batch vapor cleaning machines subject to this exemption do not exceed 188 pounds per month per stationary source; and
- e. The equipment is subject to a Permit to Operate to help facilitate verifications that the requirements of subparagraphs B.20.a, b, c, and d are met.
- f. In addition, the Section J.8 requirement to have a freeboard ratio of 1.0 or greater shall not apply to solvent cleaning machines meeting the requirements in subsections a—e above, provided the solvent cleaning machines have a freeboard ratio of 0.75 or greater.

 [Link to Note No. 29]
- 21. The Section I.3, I.4, and I.7 requirements for unheated batch cleaning machines shall not apply, provided the equipment is used in medical device manufacturing when performing incidental product cleaning in conjunction with quality assurance or quality control tests (e.g., when conducting leak testing of silicone shells) and the solvent reactive organic compound content does not exceed 900 grams per liter of material. [Link to Note No. 30]
- 22. Metal lift-off and other semiconductor and microelectromechanical device manufacturing processes involving thin film deposition, vacuum deposition, and dry etching operations; including any maintenance activities associated with such operations. [Link to Note No. 31]
- 23. The solvent container draining and filling provisions in Section D.12 shall not apply to solvent transfers out of a sump, provided the sump has a maximum capacity of 8 gallons or less, such sump is easily removed from the solvent cleaning machine, and the solvent is poured from the sump directly into a bulk storage container. [Link to Note No. 32]
- 24. Any batch vapor cleaning machine meeting all of the following requirements shall be exempt from the Section J.8 requirement to have a freeboard ratio of 1.0:
 - a. The equipment is used only for cleaning electronic components; and
 - b. The dimensions are such that the freeboard ratio is 0.75 or greater; and
 - c. The solvent cleaning machine is equipped with the freeboard refrigeration device for which the chilled air blanket temperature (expressed in degrees Fahrenheit) at the coldest point on the vertical axis in the center of the air blanket shall be no greater than 30 percent of the initial boiling point (expressed in degrees Fahrenheit) of the solvent used or no greater than minus 4 degrees Fahrenheit; and
 - d. The batch vapor cleaning machine is equipped with a superheated vapor zone where parts remain in the vapor zone for at least the minimum dwell time, as specified by the manufacturer. The temperature within the superheated vapor zone shall be at least 10 degrees Fahrenheit above the initial boiling point of the solvent being used. [Link to Note No. 33]
- C. Definitions [Link to Note No. 34]

See Rule 102 for definitions not limited to this rule. For purposes of this rule the following definitions shall apply:

- "Aerosol Product" means a hand-held, non-refillable container that expels pressurized product by means of a propellant-induced force.
- "Aerospace Vehicle" means the completed unit of any aircraft, helicopter, missile, or space vehicle.
- "Aerospace Vehicle Component" means any raw material, partial or completed fabricated part, assembly of parts, or completed unit of any aircraft, helicopter, missile, or space vehicle, including mockups and prototypes.
- "Air Blanket" means the layer of air inside the solvent cleaning machine freeboard located above the solvent/air interface.
- "Airless Solvent Cleaning Machine" means any solvent cleaning machine that is automatically operated and seals at an absolute internal pressure of 0.02 pounds per square inch absolute or less, prior to the introduction of solvent vapor into the cleaning chamber and maintains differential pressure under vacuum during all cleaning and drying cycles.

[*Link to Note No.35*]

- "Air-Tight Solvent Cleaning Machine" means any solvent cleaning machine that is automatically operated and seals at a differential pressure no greater than 0.5 pounds per square inch absolute during all cleaning and drying operations.
- "Air-Vapor Interface" means, for vapor solvent cleaners, the top of the solvent vapor layer, and the air touching this layer. The effective top of the vapor layer may be determined as the maximum height where condensation occurs on a cold metal object lowered into the vapor zone.
- "Air-Solvent Interface" means the point of contact between the exposed solvent and the air.
- "ASTM" means American Society for Testing and Materials Standards.
- "Automated Parts Handling System" means a mechanical device that carries all parts and parts baskets at a controlled speed from the initial loading of soiled or wet parts through the removal of the cleaned or dried parts. Automated parts handling systems include, but are not limited to, hoists and conveyors.
- "Batch-loaded" means material placed in a nonconveyorized container for cleaning.
- "Batch Cleaning Machine" means a solvent cleaning machine in which individual parts or a set of parts move through the entire cleaning cycle before new parts are introduced into the solvent cleaning machine. An open-top vapor cleaning machine is a type of batch cleaning machine. A solvent cleaning machine, such as a Ferris wheel or a cross-rod degreaser, that clean multiple batch loads simultaneously and are manually or semi-continuously loaded are batch cleaning machines.
- "Bench Scale Project" means a project (other than at a research and development facility) that is operated on a small scale, such as one capable of being located on a laboratory bench top.
- <u>"Carbon adsorber"</u> means a bed of activated carbon into which an air-solvent gas-vapor stream is routed and which adsorbs the solvent on the carbon.
- "Carry-out" see "Drag-out."
- "Circumferential Trough" means a receptacle located below the primary condenser that conveys condensed solvent and atmospheric moisture to a water separator.
- "Cold Cleaner" means any cleaner using solvent that, if heated, is maintained below the initial boiling point temperature. Cold cleaners include, but are not limited to, remote reservoirs, spray sinks, batch-loaded dip tanks, and cold conveyorized degreasers. Cold cleaners do not include gas/liquid path cleaners.

- "Cold Cleaning Machine" means any device or piece of equipment that contains and/or uses liquid solvent, into which parts are placed to remove soils from the surfaces of the parts or to dry the parts. Cleaning machines that contain and use heated, nonboiling solvent to clean the parts are classified as cold cleaning machines. Cold solvent wash stations are classified as cold cleaning machines.
- "Condenser" or "Primary Condenser" means a device, such as cooling coils, used to condense (liquify) solvent vapor series of circumferential cooling coils on a vapor cleaning machine through which a chilled substance is circulated or recirculated to provide continuous condensation of rising solvent vapors and, thereby, create a concentrated solvent vapor zone.
- "Condenser Flow Switch" means a safety switch connected to a thermostat that shuts off the sump heater if the condenser coolant is either not circulating or exceeds its designed operating temperature.
- "Continuous Cleaning Machine" see "In-Line Cleaning Machine."
- "Continuous Web Cleaning Machine" means a solvent cleaning machine in which parts such as film, coils, wire, and metal strips are cleaned at speeds typically in excess of 11 feet per minute. Parts are generally uncoiled, cleaned such that the same part is simultaneously entering and exiting the solvent application area of the solvent cleaning machine, and then recoiled or cut. For the purposes of this rule, all continuous web cleaning machines are considered to be a subset of in-line solvent cleaning machines.
- "Control Device" means a device for reducing emissions of reactive organic compounds to the atmosphere. [Link to Note No. 36]
- "Conveyorized (In-Line or Continuous) Cold Solvent Cleaner Cleaning Machine" means any continuously loaded solvent cleaner solvent cleaning machine that is not a conveyorized vapor solvent cleaner cleaning machine.
- "Conveyorized (In-Line or Continuous) Solvent Cleaner Cleaning Machine" means any conveyorized cold or vapor solvent cleaner cleaning machine, that uses an automated parts handling system to automatically provide a continuous supply of parts to be cleaned. including Conveyorized (in-line or continuous) cleaning machines include but are not limited to gyro, vibra, monorail, cross-rod, mesh, belt, web, and strip cleaners cleaning machines. Strip cleaners cleaning machines clean material by drawing the strip itself through the unit for cleaning prior to coating or other fabrication processes. For the purposes of this rule "Conveyorized (In-Line or Continuous) Cleaning Machine" has the same meaning as "In-Line Cleaning Machine." [Link to Note No. 37]
- "Conveyorized (In-Line or Continuous) Vapor Solvent Cleaner Cleaning Machine" means any continuously loaded solvent eleaner cleaning machine that immerses parts in boiling solvent or in solvent vapors generated by boiling solvent. Conveyorized vapor solvent cleaners (in-line or continuous) cleaning machines that contain any vapor cleaning sections shall be considered to be conveyorized vapor solvent cleaners cleaning machines for the purposes of this rule.
- "Cross-Rod Solvent Cleaning Machine" means a batch solvent cleaning machine in which parts baskets are suspended from "cross-rods" as they are moved through the machine. In a cross-rod cleaning machine, parts are loaded semi-continuously, and enter and exit the machine from a single portal.
- "Degreaser" means any equipment designed and used for holding a solvent to carry out solvent cleaning operations. Degreasers include, but are not limited to, remote reservoir cold cleaners, batch loaded cold cleaners, open top vapor solvent cleaners, and conveyorized solvent cleaners. All degreasers can be classified as one of the following: 1) cold cleaner (including remote reservoir cold cleaners), 2) batch loaded vapor solvent cleaner, or 3) conveyorized solvent cleaner. [Link to Note No. 38]
- "Downtime Mode" means the time period when a solvent cleaning machine is not cleaning parts and the sump heating coils, if present, are turned off.

- "Drag-out" or "Carry-out" means solvent carried out of a eleaner solvent cleaning machine that adheres to or is entrapped in the part being removed.
- "Drying Tunnel" means an add-on enclosure extending from the exit area of a conveyorized degreaser solvent cleaning machine that reduces drag-out losses by containing evaporating solvent.
- "Dwell" means the technique of holding parts within the freeboard area but above the vapor zone of the solvent cleaning machine. Dwell occurs after cleaning to allow solvent to drain from the parts or parts baskets back into the solvent cleaning machine.
- "Dwell Time" means the period of time when parts are held within the freeboard area of the solvent cleaning machine, after cleaning, to allow solvent to drain from the parts back into the solvent cleaning machine.
- "Electrical Apparatus Components" means the internal components such as wires, windings, stators, rotors, magnets, contacts, relays, energizers, and connections in an apparatus that generates or transmits electrical energy including, but not limited to: alternators, generators, transformers, electric motors, cables, and circuit breakers, except for the actual cabinet in which the components are housed. Electrical components of graphic arts application equipment and hot-line tools are also included in this category.
- "Electronic Components" means the portions of an assembly, including, but not limited to: circuit card assemblies, printed wire assemblies, printed circuit boards, soldered joints, ground wires, bus bars, magnetic tapes and tape drive mechanisms, discs and disc drive mechanisms, electro-optical devices (e.g., optical filters, sensor assemblies, infrared sensors, charged coupled devices, thermal electric coolers, and vacuum assemblies), solid state components, semiconductors (e.g., diodes, zeners, stacks, rectifiers, integrated microcircuits, transistors, solar cells, light sensing devices, and light-emitting devices), and other electrical fixtures, except for the actual cabinet in which the components are housed. [Link to Note No. 39]
- "Emulsion" means a suspension of small droplets of one liquid in a second liquid.
- "Emission Control Device" means a device for reducing emissions of reactive organic compounds or toxic air contaminants to the atmosphere.
- "Evaporation" means to change into a vapor, normally from a liquid state.

"Evaporative Surface Area" means:

- (1) Cold Solvent Cleaner:
 - (a) The surface area of the top of the solvent.(b) Remote Reservoir Cold Cleaner:
 The solvent drain opening area.
- (2) Vapor Solvent Cleaner: The surface area of the top of the solvent vapor air interface.
- (3) Conveyorized Solvent Cleaner:
 - (a) Cold Cleaner: The surface area of the top of the solvent.
 - (b) Remote Reservoir Cold Cleaner: The solvent drain opening area.
 - (c) Vapor Solvent Cleaner: The surface area of the top of the solvent vapor air interface. [Link to Note No. 40]
- "Existing Solvent Cleaning Operation" means solvent cleaning that is being performed as of [date of revised rule adoption].
- "Existing Solvent Cleaning Machine" means any solvent cleaning machine that is installed as of [date of revised rule adoption]
- **"Fluid System"** means a power transmission system that uses the force of flowing liquids and gases to transmit power. Fluid systems include hydraulic systems and pneumatic systems.

"Freeboard Area" means; for a batch cleaning machine, the area within the solvent cleaning machine that extends from the solvent/air interface to the top of the solvent cleaning machine; for an in-line cleaning machine, it is the area within the solvent cleaning machine that extends from the solvent/air interface to the bottom of the entrance or exit opening, whichever is lower.

"Freeboard Height" means:

- (1) Cold Solvent Cleaner: The vertical distance from the top of the solvent, or the solvent drain of a remote reservoir cold cleaner, to the top of the cold cleaner.
- (2) Batch loaded Vapor Solvent Cleaner: The vertical distance from the top of the solvent vapor air interface to the top of the solvent cleaner.
- (3) Conveyorized Solvent Cleaner:
 - (a) For non-boiling solvent, the vertical distance from the top of the solvent to the bottom of the lowest opening in the solvent cleaner where vapors can escape.
 - (b) For boiling solvent, the vertical distance from the top of the solvent vapor air interface to the bottom of the lowest opening in the degreaser where vapors can escape.

"Freeboard Height" means; for a batch cleaning machine, the distance from the solvent/air interface as measured during the idling mode or the top of the solvent drain of a remote reservoir cold cleaning machine to the top of the cleaning machine; for an in-line cleaning machine, it is the distance from the solvent/air interface to the bottom of the entrance or exit opening, whichever is lower as measured during the idling mode.

"Freeboard Ratio" means the <u>ratio of the solvent cleaning machine</u> freeboard height-divided by the <u>smaller of the inside length or the inside width (or diameter if applicable) of the solvent cleaner evaporative</u> area to the smaller interior dimension (length, width, or diameter) of the solvent cleaning machine.

"Freeboard Refrigeration Device (Also Called a 'Chiller')" means a secondary cooling coil mounted above the primary condenser that provides a chilled air blanket above the solvent vapor air-interface to cause the condensation of additional solvent vapor. A primary condenser capable of meeting the requirements of Section J.9.a or L.10.a is defined as both a freeboard refrigeration device and a primary condenser for the purposes of this rule.

"Gas/Liquid-Path Solvent Cleaner" means a solvent cleaning machine (including ancillary equipment) that applies solvent to the interior of parts, a gas turbine or jet engines, or equipment to clean gas and/or liquid paths. Gas/liquid path cleaning operations include, but are not limited to, for the removal of corrosion, or combustion deposits, propellants, moisture, residuals, or other undesirable matter. Examples of gas/liquid path cleaners include, but are not limited to, corrosion control carts (e.g., used on the interiors of gas turbine or jet engines), valve flushing systems, rocket engine flushing equipment, rocket propellant transfer line flushing and purging systems. [Link to Note No. 41]

"General Work Surface" means an area of a medical device or pharmaceutical facility where solvent cleaning is performed on work surfaces including, but not limited to, tables, countertops, and laboratory benches. General work surface shall not include items defined under janitorial cleaning.

"Guillotine Cover" means a cover that is biparting and moves in the same plane.

"Halogenated Hazardous Air Pollutant Solvent" means methylene chloride (Chemical Abstracts Service No. 75-09-2), perchloroethylene (Chemical Abstracts Service No. 127-18-4), trichloroethylene (Chemical Abstracts Service No. 79-01-6), 1,1,1-trichloroethane (Chemical Abstracts Service No. 71-55-6), carbon tetrachloride (Chemical Abstracts Service No. 56-23-5), and chloroform (Chemical Abstracts Service No. 67-66-3).

- "High-Precision Optics" means any optical element used in an electro-optical device that is designed to sense, detect, or transmit light energy, including specific wavelengths of light energy and changes in light energy levels.
- "High Vapor Cutoff Thermostat" means a device, with a manual reset, that shuts off the sump heater if the temperature at the air vapor interface rises above the designed operating level.
- "High Volatility Solvent" means any solvent that is not classified as a low volatility solvent. [*Link to Note No. 42*]
- "Hoist" means a mechanical device that carries the parts basket and the parts to be cleaned from the loading area into the solvent cleaning machine and to the unloading area at a controlled speed. A hoist may be operated by controls or may be programmed to cycle parts through the cleaning cycle automatically.
- "Idling Mode" means the time period when a solvent cleaning machine is not actively cleaning parts and the sump heating coils, if present, are turned on.
- "Initial Boiling Point" means the boiling point of a solvent liquid as defined by ASTM D-1078-9505, 'Standard Test Method for Distillation Range of Volatile Organic Liquids," ASTM International.
- "In-Line Cleaning Machine" or "Continuous Cleaning Machine" means-conveyorized solvent cleaning machine that uses an automated parts handling system, typically a conveyor, to automatically provide a continuous supply of parts to be cleaned. These units are fully enclosed except for the conveyor inlet and exit portals. In-line cleaning machines can be either cold or vapor cleaning machines. [Link to Note No. 43]
- **"Lip Exhaust"** means a system that collects solvent vapors escaping from the top of a solvent cleaner device installed at the top of the opening of a solvent cleaning machine that draws in air and solvent vapor from the freeboard area and ducts the air and vapor away from the solvent cleaning machine.
- "Liquid Leak" means any ROC containing liquid solvent leak at a rate of more than three drops per minute or any visible liquid mist.
- **"Low Volatility Solvent"** means a solvent with an initial boiling point that is greater than 120 degrees Celsius (248 degrees Fahrenheit) and with a temperature, as used, at least 100 degrees Celsius (180-212 degrees Fahrenheit) below the initial boiling point. [*Link to Note No. 44*]
- "Make-Up Solvent" means that solvent added to the solvent cleaning operation to replace solvent lost through evaporation or other means.
- "Maintenance Cleaning" means a solvent cleaning operation or activity carried out to keep clean general work areas where manufacturing or repair activity is performed, to clean tools, machinery, molds, forms, jigs and equipment. This definition does not include the cleaning of adhesive, coating, or ink application equipment.
- "Manufacturing Process" means the process of making goods or articles by hand or by machinery.
- "Medical Device" means an instrument, apparatus, implement, machine, contrivance, implant, in vitro reagent or other similar article, including any component, accessory, raw material, partial or completed fabricated part, that meets one of the following conditions:
 - . It is intended for use in the diagnosis of disease or other conditions, or in the cure, mitigation, treatment, or prevention of disease; or
 - 2. It is intended to affect the structure or any function of the body; or

3. It is defined in the National Formulary or the United States Pharmacopeia, or any supplement to them.

"Mixer" means any device that mechanically agitates the liquid solvent to enhance the cleaning process.

"Nonabsorbent Container" means any container made of nonporous material, which does not allow the migration of the liquid solvent through it.

"Nonatomized Solvent Flow" means the use of a solvent in the form of a liquid stream without atomization.

"Nonleaking Container" means a container without any liquid leaks.

"Open-Top Vapor Solvent Cleaner Cleaning Machine" means any batch loaded degreaser using solvent that is maintained above the initial boiling point temperature of the solvent. Degreasing occurs through the condensation of the resultant solvent vapor onto the surface of the workload a batch solvent cleaning machine that has its upper surface open to the air and boils solvent to create solvent vapor used to clean and/or dry parts.

"Primary Condenser" see "Condenser."

"Radiation-Effect Coating" means a material that prevents radar detection.

"Reactive Organic Compound Composite Partial Pressure" means the sum of the partial pressures of compounds defined as reactive organic compounds. Reactive organic compound composite pressure shall be calculated as follows:

$$PP_{C} = \frac{\sum_{i=1}^{n} (W_{i})(VP_{i})}{(MW_{i})} + \sum_{e=1}^{n} (W_{e}/MW_{e}) + \sum_{i=1}^{n} (W_{i}/MW_{i})}$$

Where:

W_i = Weight of the 'ith reactive organic compound, in grams

W_w = Weight of water, in grams

W_e = Weight of the "eth exempt organic compound, in grams

MW_i = Molecular weight of the '8th reactive organic compound, in grams per grams-mole

MW_w = Molecular weight of water, in grams per grams-mole

MW_e = Molecular weight of the "eth exempt compound, in grams per grams-mole

<u>PP</u>_c = Reactive organic compound composite partial pressure at 20 degrees Celsius, in millimeters of mercury

Tr

VP_i = Vapor pressure of the 'ith reactive organic compound at 20 degrees Celsius, in millimeters of mercury

"Refrigerated Freeboard Chiller" means a secondary cooling coil mounted above the primary condenser that provides a chilled air blanket above the solvent vapor air interface to cause the condensation of additional solvent vapor. see the definition for Freeboard Refrigeration Device (also called a 'Chiller')."

"Remote Reservoir Cold-Cleaner Cleaning Machine" means any device in which <u>liquid</u> solvent is pumped <u>through to</u> a sink-like work area <u>for cleaning parts and that</u> drains-immediately solvent back into an enclosed container while parts are being cleaned, <u>without forming a allowing no solvent to pool in the work</u>

<u>area</u>, through a single drain hole less than 100 square centimeters (15.5 square inches) in area into an enclosed container that is not accessible for soaking parts. A remote reservoir cold cleaning machine that uses an enclosed container that is accessible for dipping or soaking parts is also considered to be a batch cleaning machine.

"Repair Cleaning" means a solvent cleaning operation or activity carried out during a repair process.

"Repair Process" means the process of returning a damaged object or an object not operating properly to good condition.

"Research and Development" means a facility or portion thereof used to further the development of useful materials, devices, systems, or methods, including, but not limited to, design, development, and improvement of prototypes and processes. Research and development does not include the manufacturing process itself.

"Rotating Basket" means a perforated or wire mesh cylinder containing parts to be cleaned that is slowly rotated while proceeding through the degreeser solvent cleaning machine.

"Scientific Instrument" means an instrument (including the components, assemblies, and subassemblies used in their manufacture) and associated accessories and reagents that is used for the detection, measurement, analysis, separation, synthesis, or sequencing of various compounds.

"Semiconductor Manufacturing" means any process or operation producing semiconductor material, slicing or polishing semiconductor material, utilizing photoresist to manufacture intermediate products, or producing either semiconductor devices or related solid state devices.

"Silicone Manufacturing" means any process or operation producing a silicone raw material (e.g., polymer, fluid, gum, gel, elastomer, dispersion, or other bulk state silicone material). Silicone manufacturing also includes any on site preliminary processes or operations that occurs before a silicone raw material is produced.

"Soils" mean contaminants that are removed from the part or parts being cleaned. Soils include, but are not limited to, grease, oils, waxes, metal chips, carbon deposits, fluxes, and tars.

"Solvent" means "Organic Solvent."

"Solvent/Air Interface" means, for a vapor cleaning machine, the location of contact between the concentrated solvent vapor layer and the air. This location of contact is defined as the mid-line height of the primary condenser coils. For a cold cleaning machine, it is the location of contact between the liquid solvent and the air.

[<u>Link to Note</u> <u>No.45]</u>

"Solvent/Air Interface Area" means; for a vapor cleaning machine, the surface area of the solvent vapor zone that is exposed to the air; for an in-line cleaning machine, it is the total surface area of all the sumps; for a cold cleaning machine, it is the surface area of the liquid solvent that is exposed to the air, except for remote reservoir cleaning machines, in which case it is the area of the drain.

"Solvent Cleaner" means a device that applies solvent or in which solvent is applied to items for the purpose of solvent cleaning.

"Solvent Cleaning" means the use of organic solvent to remove loosely held uncured adhesives, uncured inks, uncured coatings, and other contaminants that include, but are not limited to, dirt, soil, lubricants, coolant, moisture, grease and fingerprints from parts, products, tools, machinery, equipment and general work areas. [Link to Note No. 46]

"Solvent Container" means that part of the solvent cleaner cleaning machine that is intended to hold the cleaning solvent.

"Solvent Vapor Zone" means; for a vapor cleaning machine, the area that extends from the liquid solvent surface to the level that solvent vapor is condensed. This condensation level is defined as the midline height of the primary condenser coils.

"Space Vehicle" means a vehicle designed to travel beyond the earth's atmosphere.

"Space Vehicle Component" means any raw material, partial or completed fabricated part, assembly of parts, or completed unit of any space vehicle, including mockups and prototypes.

"Spray Pump Control Switch" means a safety switch that prevents the spray pump from operating if the vapor level falls below the design operating level.

"Sump" means the part of a solvent cleaning machine where the liquid solvent is located.

"Sump Heater Coils" mean the heating system on a cleaning machine that uses steam, electricity, or hot water to heat or boil the liquid solvent.

"Superheated Vapor System" means a system that heats the solvent vapor, either passively or actively, to a temperature above the solvent's initial boiling point. Parts are held in the superheated vapor before exiting the machine to evaporate the liquid solvent on them. Hot vapor recycle is an example of a superheated vapor system.

"Superheated Vapor Zone" means any region located within the vapor zone of a vapor cleaning machine whereby solvent vapors are heated above the solvent's initial boiling point.

"Ultrasonics" means enhancement of the cleaning process by agitation of liquid solvents with high frequency sound wave vibrations.

"Vapor Cleaning Machine" means a batch or in-line solvent cleaning machine that boils liquid solvent generating solvent vapor that is used as a part of the cleaning or drying cycle.

"Vapor Level Control Switch or Vapor Level Control Thermostat" see "High Vapor Cutoff Thermostat."

"Vapor Solvent Cleaner" means any solvent cleaners that cleans through the condensation of hot solvent vapor on colder workloads.

"Waste Solvent Residue" means sludge that may contain dirt, oil, metal particles, and/or other undesirable waste products concentrated after heat distillation of the waste solvent either in the solvent <u>cleaner cleaning</u> machine itself or after distillation in a separate still.

"Water Layer" means a layer of water that floats above the denser solvent and provides control of solvent emissions. In many cases, the solvent used in batch cold cleaning machines is sold containing the appropriate amount of water to create a water cover.

"Wipe Cleaning" means that method of cleaning that uses a material such as a rag wetted with a solvent, coupled with a physical rubbing process to remove contaminants from surfaces.

"Workload" means the objects put in a eleaner solvent cleaning machine for the purpose of removing oil, grease, soil, coating, dirt, moisture, or other undesirable matter from the surface of the objects.

"Workload Area" means:

- (1) The plane geometric surface area of the top of the submerged parts basket, or
- (2) The combined plane geometric surface area(s) displaced by the submerged workload, if no basket is used.
- **D.** General Operating Requirements. Any person who <u>owns, operates, or</u> uses any solvent <u>cleaner-cleaning</u> machine or <u>performs any solvent cleaning</u> shall <u>ensure such operation</u> conforms to the following operating requirements:

[*Link to Note No.47*]

- 1. All Ssolvent, including waste solvent and waste solvent residue, and waste solvent cleaning materials such as cloth, paper, etc. shall not be stored or disposed of in a manner that will cause or allow evaporation into the atmospherein nonabsorbent and nonleaking containers equipped with tight-fitting covers. The covers shall be in place unless adding material to or removing material from the containers, the containers are empty, or doing maintenance/inspection of the containers. Containers shall have a label indicating the name of the solvent/material they contain. After distillation recovery of waste solvent, solvent residues shall not contain more than 20 percent solvent of reactive organic compound by weight.
- 2. The solvent <u>cleanercleaning machine</u>, ventilation system, and <u>/or</u> emission control equipment shall be installed, operated, and maintained <u>in proper working order consistent with the manufacturer's specifications</u>.
- 3. Solvent The cleaning or solvent vapor cleaning of porous or absorbent materials, such as cloth, leather, wood, or rope, is prohibited. This provision shall not apply to paper gaskets, paper filters, and medical devices.
- 4. The All solvent containers holding solvent shall be free of all-liquid leaks. Auxiliary cleaner Solvent cleaning machine equipment, such as covers, pumps, water separators, steam traps, or distillation units shall not have any liquid leaks, visible tears, holes, or cracks. Any such liquid leak, visible tear, hole, or crack that is detected shall be repaired within one day from discovery-by the operator, or the eleaner-solvent cleaning machine shall be drained of all solvent, in a manner authorized by this Ruleconsistent with Section D.12 provisions, and shut down until replaced or repaired. Solvent eleaners cleaning machines shall not be operated when leaking.
- 5. Covers <u>and other closure devices (e.g., valves or drain plugs)</u> designed to reduce solvent evaporation shall not be removed <u>or opened</u> except to process work or to perform <u>monitoring</u>, <u>inspections</u>, <u>maintenance</u>, <u>or repairs that require the removal of the covers or other closure devices</u>. <u>Solvent cleaning machines shall not be operated when performing maintenance or repairs</u>.
- 6. For solvent <u>degreaser_cleaning machine</u> operations <u>other than gas-path solvent cleaners and continuous web cleaning machines</u>, solvent carry-out shall be minimized by the following methods, as applicable:
 - a. <u>Except for remote reservoir cold cleaning machines, The the</u> workload shall be racked.
 - b. For manual operations, any pools of solvent remaining on the cleaned parts shall be tipped out before removing them from the cleaner. Parts having cavities, holes, or blind holes shall be tipped or rotated before being removed from the solvent cleaning machine such that the solvent in the cavities, holes, or blind holes is returned to the solvent container.
 - e. Pools of solvent shall be drained by a device.

- dc. The workload shall be drained within the freeboard area so that the drained solvent is returned to the solvent container.
- <u>ed</u>. For cold solvent cleaning, parts shall be drained immediately after cleaning, until one of the following conditions exists:
 - 1) At least 15 seconds have elapsed; or
 - 2) Dripping of solvent ceases; or
 - 3) The parts become visibly dry.
- <u>For automated parts handling systems, The workload shall be moved in and out of the degreaser solvent cleaning machine at less than 3.33.4 meters per minute (11.2 feet per minute).</u>
- 7. For solvent <u>degreaser_cleaning machine</u> operations other than gas-path solvent cleaners and <u>continuous web cleaning machines</u>, solvent flow shall be directed downward to avoid turbulence at the <u>air_vapor_or_air_solvent_solvent/air_interface</u> and to prevent liquid solvent from splashing outside of the <u>cleaner_solvent cleaning machine</u>. <u>If a flexible hose or flushing device is used</u>, flushing shall be performed only within the freeboard area of the solvent cleaning machine.
- 8. For solvent <u>degreaser cleaning machine</u> operations <u>other than gas-path solvent cleaners</u>, solvent flow shall not be used in a manner such that liquid solvent splashes outside the container.
- 9. Solvent atomization operations (e.g., blow drying) shall not be atomized unless be it is vented to an emission control system that meets the requirements of Rule 321 Section MN.
- 10. Any solvent spills shall be wiped up immediately and the used absorbent material (e.g., cloth, paper, sand, sawdust, etc.) shall be stored in closed containers that are handled in accordance with Section D.1.
- 11. Solvent levels shall not exceed the solvent cleaning machine's fill line.
- 12. Draining or filling solvent containers shall be performed at a level lower than the liquid solvent surface.
- 13. When using a ventilation fan, it shall not be positioned in such a way as to direct air flow near a solvent cleaning machine opening. [Link to Note No. 49]
- E. Additional Operating Requirements for Open-top-Batch Vapor Solvent Cleaners Cleaning Machines and In-Line Conveyorized-Vapor Solvent Cleaners Cleaning Machines. In addition to the general operating requirements specified above in Rule 321 Section D, aAny person who owns, operates, or uses any open-top-batch vapor solvent cleaner-cleaning machine or any conveyorized-in-line vapor solvent cleaner-cleaning machine shall ensure the equipment operation conforms to the following operating requirements:
 - 1. The degreaser shall be covered whenever the cooling system is off. Except to perform monitoring, inspections, maintenance, or repairs that require the removal of the covers:
 - Idling mode covers shall be closed or in place when the equipment is in an idling mode.
 - b. Downtime mode covers shall be closed or in place when the equipment is in a downtime mode.

[*Link to Note No.48*]

- 2. When starting the <u>degreaser solvent cleaning machine</u>, the <u>cooling system primary condenser shall</u> be turned on before <u>or simultaneously with</u> the sump heater.
- 3. When shutting down the <u>degreaser solvent cleaning machine</u>, the sump heater shall be turned off <u>and the solvent vapor layer allowed to collapse</u> before <u>or simultaneously with</u> the <u>cooling system</u> primary condenser is turned off.
- 4. The workload shall be <u>degreased cleaned</u> in the vapor zone for at least 30 seconds or until condensation ceases.
- 5. Parts shall be allowed to dry within the <u>degreaser solvent cleaning machine</u> until the exterior surface of the parts become visually dry.
- 6. Solvent spray shall be kept at least 10 centimeters (3.94 inches) below the air vapor solvent/air interface.
- 7. The workload area shall not occupy more than half of the evaporative surface area solvent/air interface area of the solvent-eleaner cleaning machine.
- 8. For <u>cleaners solvent cleaning machines</u> equipped with water separators, water shall not be visibly detectable in the solvent phase exiting the water separator, nor shall solvent be visibly detectable in the aqueous phase leaving the separator.
- 9. If equipped with a superheated vapor zone:
 - a. The manufacturer's specifications for determining the minimum proper dwell time within the superheated vapor system shall be followed.
 - Parts and parts baskets shall remain in the vapor zone for at least the minimum proper dwell time.
 - c. The temperature within the superheated vapor zone shall be at least 10 degrees Fahrenheit above the initial boiling point of the solvent being used.
- F. Additional Operating Requirements for Gas/Liquid-Path Cleaners Solvent Cleaners. In addition to the operating requirements specified in Rule 321 Sections D.1—D.5 and D.9, aAny person who owns, operates, or uses using any gas/liquid path cleaner gas-path solvent cleaner shall ensure the equipment operation conforms to the following operating requirements:
 - 1. Cleaned parts or equipment shall be drained until dripping ceases or 15 seconds have elapsed.
 - 2. The cover of the solvent <u>container(s)</u>, reservoir(s) and opening(s) of a solvent collection system shall be closed at all times except when the reservoir is being filled, emptied, cleaned, repaired or inspected to process work or to perform monitoring, inspections, maintenance, or repairs that require the removal of the covers or other closure devices.
- General Equipment Requirements for Solvent Cleaners Cleaning Machines. Any person who owns, operates, or uses All-any solvent cleaning machine shall ensure that it is equipped with conform to the following requirements:
 - 1. A container shall be used for the solvent.
 - 2. Except for remote reservoir cold <u>cleaners cleaning machines</u> using low volatility solvents, <u>all</u> <u>cleaners shall be equipped with an apparatus or cover(s) to completely cover the solvent container when not processing work.</u>

- 3. Solvent degreasers shall be equipped with a facility Except for gas-path solvent cleaners using a solvent with a reactive organic compound content of 50 grams per liter of material or less, an apparatus or a device for draining cleaned parts such that the drained solvent or drag-out is returned to the cleaner solvent tankcontainer.
- 4. The A list of the applicable operating requirements. At a minimum, the list shall include the applicable operating requirements contained in Rule 321 Sections D, E, and F. The list of operating requirements shall be legibly written legible and permanently and conspicuously posted or maintained on or near the equipment in such a manner that it is conveniently available to the operator for reference purposes.
- 5. Where solvent agitation is used, the equipment that achieves agitation shall be achieved by use of using pump recirculation, mechanical mixing (a mixer), or ultrasonics. Gas or air agitation shall not be used. When a pump-agitated solvent bath is used, the pump agitator shall be designed to produce a rolling motion of the solvent without any observable splashing against tank walls or parts being cleaned.
- 6. When employing solvent flow, with a solvent degreaser, the flow shall only be a flexible hose or flushing device that produces only a continuous fluid stream. An atomized or shower type spray shall not be used. I unless it is used in an conveyorized in-line or enclosed eleanersolvent cleaning machine, a shower type spray may be used provided that where the spray is conducted in a totally confined space that is sealed from the atmosphere.
- 7. Any degreaser equipped with Where a hood, enclosure, or lip exhaust, or a lip exhaust connected to a hood or enclosure is employed, shall not have an a blower or fan such that the air ventilation rate in excess of shall not exceed 20 cubic meters per minute per square meter (65.6 cubic feet per minute per square feet) of air vapor or air solvent solvent/air interface surface area, unless necessary to meet a National Institute for Occupational Safety and Health standard.
- 8. Effective July 17, 1997, no person shall install or add a lip exhaust to a degreaser When a lip exhaust unless it is is installed or added after July 17, 1997, vented to an emission control system that meets the requirements of Rule 321 Section M.
- 9. <u>A The average draft rate in the solvent cleaner</u> workroom having an average draft rate, as measured parallel to the plane of the degreaser solvent cleaning machine opening, shall not exceeding- 9.1 meters per minute (30 feet per minute), unless necessary to meet a National Institute for Occupational Safety and Health standard.
- 10. Ventilation fans shall not be positioned in such a way as to direct air flow near the degreaser openings.
- When employing an automated parts handling system, The vertical equipment such that the speed of any powered hoist or conveyor of the parts shall not exceed 3.33.4 meters per minute (11.2 feet per minute).
- H. Additional Equipment Requirements for Remote Reservoir Cold Cleaners Cleaning Machines. In addition to the requirements in Rule 321 Section G, Any person who owns, operates, or uses any remote reservoir cold eleaner equipment cleaning machine shall ensure that it is equipped with meet the following requirements:
 - 1. The A sink or work area shall be that is sloped sufficiently towards the drain to prevent pooling of solvent
 - 2. There shall be a \underline{A} single drain hole, not larger than 100 square centimeters (15.5 square inches) in area, for the solvent to flow from the sink into the enclosed reservoir.

- 3. Except for remote reservoir cold cleaners when using low volatility solvents, a cover or a device, such as a valve or a drain plug, to prevent or minimize the solvent vapor emissions shall be prevented from escaping from the solvent container by means of closing a cover or a device, such as a valve or a drain plug, when the remote reservoir is not being used, cleaned, or repaired not processing work or performing monitoring, inspections, maintenance, or repairs that require the removal of the cover or device.
- 4. The A freeboard height shall be of 6 inches or higher.
- 5. The unit shall have a When the solvent is heated above 50 degrees Celsius (122 degrees Fahrenheit), or it is agitated, or the solvent is a high volatility solvent, dimensions such that the freeboard ratio of is 0.75 or greater, if the solvent is heated above 50 degrees Celsius (122 degrees Fahrenheit), agitated, or a high volatility solvent is used.
- 6. In lieu of the freeboard height required by Rule 321-Section H.4 or the freeboard ratio required by Rule 321-Section H.5, one of the following requirements shall-may be met:
 - a. a A water cover layer at a minimum thickness of 2.5 centimeters (1.0 inch) on the surface of the solvent within the cleaning machine at least 1 inch deep shall be used, provided the solvent is insoluble in water and has a specific gravity greater than 1, or
 - b. <u>aAn</u> emission control system that meets the requirements of <u>Rule 321</u> Section <u>M-N</u> shall be used.
- 7. Effective [one year from the date of revised rule adoption], except when using an emission control system that meets the requirements of Section N, solvent that contains 50 grams of reactive organic compound per liter of material or less. [Link to Note No. 50]
- I. Additional Equipment Requirements for <u>Batch Cold Cleaners Cleaning Machines</u>. In addition to the requirements specified in Rule 321 Section G, Any person who owns, operates, or uses any batch cold eleaners cleaning machine other than a remote reservoir cold cleaning machine shall ensure that it is equipped with include all of the following:

[*Link to Note No.51*]

- 1. When using a high volatility solvent, the unit shall be equipped with a cover that is a sliding, rolling, or guillotine type that is designed to easily open and close. If a mechanized batch cold cleaning machine (e.g., a manually loaded or semi-continuously loaded Ferris wheel or cross-rod solvent cleaning machine) is used with a high volatility solvent, the unit shall be equipped with a downtime mode cover.
- 2. A method for draining cleaned parts, so the drained solvent is returned to the container. If using a high volatility solvent, the drainage facility apparatus or device required by Section G.3 shall be internal so that the cleaned parts are within the solvent cleaner cleaning machine and under the cover while draining. The drainage facility apparatus or device may be external where the internal type cannot fit into the cleaning system provided the drained solvent is returned to the solvent container.
- 3. When using a low volatility solvent that is not agitated, the a freeboard height shall be of 6 inches or higher or dimensions such that a the freeboard ratio of is 0.5 or greater shall be maintained.
- 4. The unit shall have a When the solvent is heated above 50 degrees Celsius (122 degrees Fahrenheit), or it is agitated, or the solvent is a high volatility solvent, dimensions such that the freeboard ratio of is 0.75 or greater, if the solvent is heated above 50 degrees Celsius (122 degrees Fahrenheit), agitated, or a high volatility solvent is used.
- 5. In lieu of the freeboard height or freeboard ratio required by Rule 321-Section I.3 or the freeboard ratio required by Section I.4, one of the following requirements may be met:

- a. a water cover at least 1 inch deep shall be used, provided the solvent is insoluble in water and has a specific gravity greater than 1A water layer at a minimum thickness of 2.5 centimeters (1.0 inch) on the surface of the solvent within the cleaning machine shall be used, or
- b. aAn emission control system shall be used that meets the requirements of Rule 321 Section M N shall be used.
- 6. A permanent, conspicuous mark shall be maintained locating denoting the maximum allowable solvent level conforming to the applicable freeboard requirements. This requirement does not apply if employing a water cover-layer or an emission control system per Rule 321 Section I.5.
- 7. Effective [one year from the date of revised rule adoption], except when using an emission control system that meets the requirements of Section N, solvent that contains 50 grams of reactive organic compound per liter of material or less. [Link to Note No. 52]
- J. Additional Equipment Requirements for Open-top Batch Vapor Solvent Cleaners Cleaning

 Machines. In addition to the requirements specified in Rule 321 Section G, open top Any person who owns, operates, or uses any batch vapor solvent cleaners cleaning machine shall ensure that it is equipped with include all of the following:
 - 1. <u>For open-top vapor cleaning machines, A-a cover that is a sliding, rolling, or guillotine type that is designed to easily open and close without disturbing the vapor zone. This requirement does not apply to open-top vapor solvent degreasers cleaning machines equipped with top enclosures, provided:</u>
 - a. the operator only opens the enclosure cover(s) or door(s) when the condenser is operative or when the degreaser solvent cleaning machine is shut down, and
 - b. the <u>degreaser solvent cleaning machine</u> <u>evaporative surface areasolvent/air interface area</u> is less than 1 square meter (10.8 square feet), and
 - c. the <u>degreaser-solvent cleaning machine</u> cover is designed such that it can be opened and closed easily without disturbing the vapor zone.
 - 2. For mechanized batch vapor cleaning machines (e.g., a manually-loaded or semi-continuously-loaded Ferris wheel or cross-rod solvent cleaning machine), idling and downtime mode covers.
 - 23. A primary condenser coil-situated above the boiling solvent.
 - A condenser flow switch that <u>automatically</u> shuts off the sump heater if the condenser coolant stops circulating or becomes warmer than its designed operating temperature.
 - 45. A high vapor <u>level cutoff thermostat control device</u> that <u>automatically</u> shuts off the sump heater <u>when if</u> the <u>solvent</u>-vapor level <u>in the vapor cleaning machine</u> rises above the <u>designed operating level height of the primary condenser</u>.
 - 56. For degreasers solvent cleaning machines with solvent flow, a device such as a spray pump control switch that prevents the solvent flow pump operation unless the solvent vapor level is at the designed operating level.
 - 7. A device that automatically shuts off the sump heat if the sump liquid solvent level drops to the sump heater coils.

- 68. A-Dimensions such that the freeboard ratio of is 0.75 or greater. Effective [one year from the date of revised rule adoption], the unit shall have dimensions such that the freeboard ratio is 1.0 or greater.
- 79. Cleaners For solvent cleaning machines with an evaporative surface area a solvent/air interface area of 1 square meter (10.8 square feet) or greater-shall be equipped with one of the following:
 - a. A refrigerated freeboard chiller freeboard refrigeration device for which the chilled air blanket temperature (expressed in degrees Fahrenheit) at the coldest point on the vertical axis in the center of the air vapor interface air blanket shall be no greater than 30 percent of the initial boiling point (expressed in degrees Fahrenheit) of the solvent used or no greater than 40 degrees Fahrenheit. If the chiller operates below 32 degrees Fahrenheit, it shall be equipped with an automatic defrost; or
 - b. An enclosed design in which the cover or door opens only when the dry part is actually entering or exiting the cleaner solvent cleaning machine.
- 810. In lieu of the freeboard ratio required by Rule 321-Section J.68 or the freeboard chiller/enclosed design required by Section J.79, an emission control system that meets the requirements of Section M-N may be used.
- 11. Effective [one year from the date of revised rule adoption], except when an emission control system that meets the requirements of Section N is employed, when using solvent containing in excess of 50 grams of reactive organic compound per liter of material:
 - a. An automated parts handling system;
 - b. A circumferential trough;
 - c. A water separator (not required for solvents that form azeotropes with water);
 - d. A freeboard refrigeration device that is operated such that the chilled air blanket temperature, measured at the center of the air blanket, is no greater than 40 percent of the initial boiling point of the solvent, in degrees Fahrenheit, for solvents that do not form azeotropes with water, or 50 percent of the initial boiling point, in degrees Fahrenheit, for solvents that form azeotropes with water; and
 - e. A superheated vapor zone where parts remain in the vapor zone for at least the minimum dwell time, as specified by the manufacturer. The temperature within the superheated vapor zone shall be at least 10 degrees Fahrenheit above the initial boiling point of the solvent being used. [Link to Note No. 53]
- K. Additional Equipment Requirements for Conveyorized In-Line Cold Cleaners Cleaning Machines. In addition to the requirements specified in Rule 321 Section G, conveyorized Any person who owns, operates, or uses any batch in-line cold cleaners cleaning machine shall ensure that it is be equipped with the following:
 - 1. A rotating basket, tumbling basket, drying tunnel, or other means that prevents cleaned parts from carrying out solvent liquid or vapor.
 - 2. <u>Openings such that Tthe average clearance between workload material and the edges of the cleaner-solvent cleaning machine entrance and exit openings shall be less than 10 centimeters (3.94 inches) or less than 10 percent of the opening width, whichever is less.</u>
 - 3. Down-time <u>mode</u> covers for closing off the entrance and exit during shutdown hours, or an equivalent device that cover at least 90 percent of the opening. A continuous web part that

completely occupies an entry and exit port when the machine is idle is considered to meet this requirement.

- 4. A <u>Dimensions such that the freeboard ratio of is 0.75</u> or greater that is physically verifiable.
- 5. In lieu of the freeboard ratio required by Rule 321 Section K.4, use of an emission control system that meets the requirements of Section MN may be used.
- 6. Effective [one year from the date of revised rule adoption], except when using an emission control system that meets the requirements of Section N, solvent that contains 50 grams of reactive organic compound per liter of material or less. [Link to Note No. 54]
- L. Additional Equipment Requirements for Conveyorized In-Line Vapor Solvent Cleaners Cleaning

 Machines. In addition to the requirements specified in Rule 321 Section G, conveyorized Any person who owns, operates, or uses any in-line vapor solvent cleaners cleaning machine shall ensure that it is be equipped with the following:
 - 1. A rotating basket, tumbling basket, drying tunnel, or other means that prevents cleaned parts from carrying out solvent liquid or vapor.
 - 2. <u>Openings such that Tthe average clearance between workload material and the edges of the eleaner-solvent cleaning machine entrance and exit openings shall be less than 10 centimeters (3.94 inches) or less than 10 percent of the opening width, whichever is less.</u>
 - 3. <u>Idling and Ddown-time mode covers for closing off the entrance and exit during shutdown hours, or an equivalent device that cover at least 90 percent of the opening. A continuous web part that completely occupies an entry and exit port when the machine is idle is considered to meet this requirement.</u>
 - 4. A primary condenser coil-situated above the boiling solvent.
 - 5. A condenser flow switch that <u>automatically</u> shuts off the sump heater if the condenser coolant stops circulating or becomes warmer than its designed operating temperature.
 - 6. A high-vapor level eutoff thermostat control device that automatically shuts off the sump heater when if the solvent-vapor level in the vapor cleaning machine rises above the designed operating level height of the primary condenser.
 - 7. For <u>degreasers solvent cleaning machines</u> with solvent flow, a <u>device such as a spray pump</u> control switch <u>device</u> that prevents the solvent flow pump operation unless the solvent vapor level is at the designed operating level.
 - 8. A device that automatically shuts off the sump heat if the sump liquid solvent level drops to the sump heater coils.
 - 89. A-<u>Dimensions such that the freeboard ratio of is 0.75</u> or greater that is physically verifiable.

 Effective [one year from the date of revised rule adoption], the unit shall have dimensions such that the freeboard ratio is 1.0 or greater.
 - 910. In lieu of the freeboard ratio required by Rule 321-Section L.89, one of the following shall-may be met:
 - a. A <u>refrigerated freeboard chiller freeboard refrigeration device</u> for which the chilled air blanket temperature (expressed in degrees Fahrenheit) at the coldest point on the vertical axis in the center of the <u>air vapor interface air blanket</u> shall be no greater than 30 percent of the initial boiling point (expressed in degrees Fahrenheit) of the solvent used or no

- greater than 40 degrees Fahrenheit. If the chiller operates below 32 degrees Fahrenheit, it shall be equipped with an automatic defrost; or
- b. An emission control system that meets the requirements of Rule 321-Section M-N shall be used.
- 11. Effective [one year from the date of revised rule adoption], except when an emission control system that meets the requirements of Section N is employed, when using solvent containing in excess of 50 grams of reactive organic compound per liter of material:
 - a. A circumferential trough;
 - b. A water separator (not required for solvents that form azeotropes with water);
 - c. A freeboard refrigeration device that is operated such that the chilled air blanket

 temperature, measured at the center of the air blanket, is no greater than 40 percent of the
 initial boiling point of the solvent, in degrees Fahrenheit, for solvents that do not form
 azeotropes with water, or 50 percent of the initial boiling point, in degrees Fahrenheit, for
 solvents that form azeotropes with water; and
 - d. A superheated vapor zone where parts remain in the vapor zone for at least the minimum dwell time, as specified by the manufacturer. The temperature within the superheated vapor zone shall be at least 10 degrees Fahrenheit above the initial boiling point of the solvent being used. [Link to Note No. 55]
- M. Requirements Solvent Cleaning. [Link to Note No. 56]

Section M requirements apply to any person performing solvent cleaning, including, but not limited to, use of wipe cleaning cloths, cotton swabs, dabber bottles, hand-held spray bottles, squirt bottles, aerosol products, and the cleaning of application equipment. The following requirements become effective [one year from the date of revised rule adoption] and are in addition to the general operating requirements specified in Section D.

1. Solvent Requirements. Except when using an emission control system that meets the requirements of Section N, no person shall use any solvent to perform solvent cleaning which exceeds the applicable grams of reactive organic compound per liter of material limit specified in Table 1.

Table 1: Reactive Organic Compound Content Limits for Solvent Cleaning

		1
SOLVENT CLEANING ACTIVITY	ROC Limit, grams of ROC per liter of material (pounds of ROC per gallon ^a)	
(a) Product Cleaning During Manufacturing Processes and Surface P	reparation for Coating	
Application:		
(i) General	<u>50</u> (0.42)	[Link to Note No.57]
(ii) Electrical Apparatus Components & Electronic Components	900 (7.51)	[Link to Note
(iii) Medical Devices & Pharmaceuticals	900 (7.51)	<u>No.58</u>]
(iv) Silicone Manufacturing	900 (7.51)	Link to Note No.59
(b) Repair Cleaning and Maintenance Cleaning:		
(i) General	<u>50</u> (0.42)	Link to Note No.57
(ii) Electrical Apparatus Components & Electronic Components	900 (7.51)	
(iii) Medical Devices & Pharmaceuticals:		[Link to Note
(I) Tools, Equipment, & Machinery	900 (7.51)	<u>No.58</u>]
(II) General Work Surfaces	900 (7.51)	J
(iv) Silicone Manufacturing	900 (7.51)	[Link to Note No.59]
(c) Cleaning of Coatings Application Equipment	950 (7.93)	[<i>Link to Note No.58</i>]
(d) Cleaning of the Following Items and Equipment and their Components:		
(i) Aerospace Vehicles; (ii) Aerospace Vehicle Payloads and Satellites; (iii) Aerospace Vehicle, Aerospace Vehicle Payload, and Satellite: (I) Transport Equipment (e.g., railcars, trucks, trailers, forklifts, and containers), and (II) Support Processing Equipment (e.g., clean rooms, tools, payload fairing fixtures, alignment jigs, fuel and oxidizer loading carts and associated transfer	900 (7.51)	[Link to Note No.60]

^a English units are provided for information only.

- Cleaning Devices and Methods. Except for solvent cleaning of spray application equipment, any person performing solvent cleaning with a solvent containing more than 50 grams per liter of material shall use one or more of the following cleaning devices or methods: [Link to Note No. 61]
 - a. Wipe cleaning where solvent is dispensed to wipe cleaning materials from containers that
 are kept closed to prevent evaporation, except while dispensing solvent or replenishing
 the solvent supply;
 - b. Application of solvent from hand-held spray bottles, squirt bottles, or other closed containers with a capacity of one liter or less; or
 - c. Non-atomized solvent flow, dip, or flush method where pooling on surfaces being cleaned is prevented or drained, and all solvent runoff is collected in a manner that enables solvent recovery or disposal. The collection system shall be kept closed to prevent evaporation except while collecting solvent runoff or emptying the collection system.
- 3. Solvent Cleaning of Spray Application Equipment. Any person cleaning spray application equipment with a solvent containing more than 50 grams of reactive organic compound per liter of material shall use an enclosed system, or equipment that is proven to the satisfaction of the Control Officer to be equally effective as an enclosed system at controlling emissions. If an enclosed system is used, it shall totally enclose spray guns, cups, nozzles, bowls, and other parts during washing, rinsing and draining procedures, and it shall be used according to the manufacturer's recommendations and be closed when not in use. [Link to Note No. 62]
- MN. Emission Control System Requirements. Any person who owns, operates, or uses any emission control system required by owning or operating a solvent cleaner subject to this rule may use Sections D.9, G.8, or T.2.b.4) an emission control system or as an alternative compliance method as provided for in this rule to Rule 321 Sections D.9, G.8, H.6.b, I.5.b, J.8, K.5, or L.9.b, provided that shall ensure that the following requirements are met: [Link to Note No. 63]
 - 1. The overall efficiency (the capture system efficiency multiplied by the emission control device efficiency) of the total system shall not be less than 85 percent by weight in reducing total reactive organic compound and toxic air contaminant emissions. [Link to Note No. 64]
 - 2. When using <u>a carbon-adsorption adsorber</u>, the system exhaust shall be no more than 25 parts per million of <u>solvent-reactive organic compound</u> by volume, calculated as carbon, over a complete adsorption cycle,
 - 3. The emission collection system shall have a ventilation rate between 15 to 20 cubic meters per minute per square meter of air vapor or air solvent solvent/air interface area (49.2 to 65.6 cubic feet per minute per square feet of air vapor or air solvent solvent air interface surface area), unless otherwise required to meet a National Institute for Occupational Safety and Health standard.
 - 4. An application for installation of the emission control equipment is submitted and the Control Officer grants an Authority to Construct for the equipment.
 - 5. An initial source test is accomplished by [one year from the date of revised rule adoption] or a later deadline established in an Authority to Construct to demonstrate compliance with the overall efficiency of the total system and/or the 25 parts per million reactive organic compound by volume limits of this rule. [Link to Note No. 65]
 - 6. Compliance through the use of an emission control system will not result in reactive organic compound emissions in excess of the reactive organic compound emissions which would result from compliance with Sections H.7, I.7, K.6, or M.1. [Link to Note No. 66]

- O. Alternative Operating and Equipment Requirements for an Airless Solvent Cleaning Machine or an Air-Tight Solvent Cleaning Machine. In lieu of meeting the requirements of Sections E through L, any person may use an airless solvent cleaning machine or air-tight solvent cleaning machine provided all of the following requirements are met: [Link to Note No. 67]
 - 1. The equipment is operated in accordance with the manufacturer's specifications and operated with a door or other pressure sealing apparatus that is in place during all cleaning and drying cycles.
 - 2. No pressure relief device shall allow liquid solvent to drain out.
 - 3. A differential pressure gauge shall be installed to indicate the sealed chamber pressure.
 - 4. A list of operating requirements shall be legible and conspicuously posted or maintained on or near the equipment in such a manner that it is conveniently available to the operator for reference purposes.

NP. Test Methods.

Any person who owns, operates, or uses any solvent cleaning machine or performs any solvent cleaning shall comply with the following test methods:

- 1. The reactive organic compound content of solvents shall be measured by the Environmental Protection Agency Reference Method 24 (40 CFR, Part 60, Appendix A-7).
- 2. The initial boiling point of solvents shall be determined by ASTM D-1078-8605, "Standard Test Method for Distillation Range of Volatile Organic Liquids-," ASTM International.
- 3. The capture system efficiency shall be determined in accordance with the Environmental Protection Agency method described in 40 CFR, §52.741(a)(4)(iii) when the emission control system is used for reducing emissions of reactive organic compounds. For emission control systems handling compounds that are toxic air contaminants but not reactive organic compounds, the capture system efficiency shall be determined by using the same aforementioned method modified in a manner approved by the Control Officer to quantify the mass of liquid or gaseous reactive organic compounds and/or toxic air contaminants.
- 4. The emission control device efficiency shall be determined pursuant to the Environmental Protection Agency method described in 40 CFR, §52.741(a)(4)(iv). 51, Appendix M, methods 204-204F, when the emission control system is used for reducing emissions of reactive organic compounds. For emission control systems handling any compound that is a toxic air contaminant but not a reactive organic compound, the emission control device efficiency shall be determined using:
 - a. an Environmental Protection Agency approved test method or methods, or
 - b. in the case where there is no Environmental Protection Agency approved test method, a
 Control Officer approved detection method applicable for each target toxics specie.
 - c. Several Environmental Protection Agency and/or Control Officer approved test methods on the emission control device efficiency may need to be employed to demonstrate that the emission control system overall efficiency is at least 85 percent by weight in reducing emissions of reactive organic compounds and/or toxic air contaminants. In addition, techniques to convert parts per million by volume test method results to 1) parts per million by weight and/or 2) mass emission rates (e.g., pounds per hour) shall be approved by the Control Officer.

- 5. The volumetric flowrate shall be determined in accordance with the Environmental Protection Agency Methods 2, 2A, 2C, and 2D, 2F, or 2G (40 CFR, Part 60, Appendix A-1). [*Link to Note No.* 68]
- 6. The average workroom draft rate shall be measured parallel to the plane of the <u>degreaser-solvent</u> <u>cleaning machine</u> opening with a thermistor anemometer with an accuracy within ± 2 feet per minute and a calibration pursuant to the National Institute of Standards and Technology.
- 7. The identity of components in solvents shall be determined using manufacturer's formulation data or by using ASTM E 168-6706, "Standard Practices for General Techniques of Infrared Quantitative Analysis," ASTM International, ASTM E 169-8704, "Standard Practices for General Techniques of Ultraviolet-Visible Quantitative Analysis," ASTM International, or ASTM E 260-8596 (2006), "Standard Practice for Packed Column Gas Chromatography," ASTM International.
- 8. Emissions of ROC_reactive organic compounds from the exhaust of an emission control system shall be measured by the appropriate EPA_Environmental Protection Agency Method 18 or 25, or, if applicable, 25A or 25B may be used (40 CFR, Part 60, Appendix A-7), with gas chromatography-flame ionization detection speciation analysis for C1, C2, C3, C4, C5, C6+ species. Alternatively, the Environmental Protection Agency Method 25 or 25A in combination with Method 18 may be used.
- Operational and Maintenance Plan. Any person proposing to use an emission control device to comply with this rule pursuant to Rule 321-Section M-N shall submit, with the Authority to Construct application, an emission control device Operation and Maintenance Plan to the Control Officer for approval. Owners or operators of emission control devices installed as of July 17, 1997, if not previously submitted, shall submit Operation & Maintenance Plans by January 17, 1998 and obtain approval of the plan by the Control Officer. The Operation and Maintenance Plan shall specify:

[Link to Note No.69]

- 1. operation and maintenance procedures of emissions-producing operation, and
- 2. which records shall be kept to document these operation and maintenance procedures.
- 3. <u>In addition, These these</u> records shall comply with the requirements of Rule 321-Section PR.1.c and P.3R.3. The Operation and Maintenance Plan shall be implemented upon approval of the Control Officer.

PR. Recordkeeping Requirements.

- 1. Any person holding a permit for who owns, operates, or uses a solvent cleaning machine or performs solvent cleaning that is subject to this rule shall comply with the following requirements:
 - a. Record and Mmaintain and have available on site solvent manufacturer specification sheets that show the following information for each solvent:
 - Type of solvent (chemical or manufacturer's product name). Brand name, stock
 identification number, and generic product class for each solvent used during the
 month at the stationary source.
 - 2) The solvent initial boiling point. Material safety data sheets for each material listed in response to Section R.1.a.1).
 - 3) Purchase records for each material listed in response to Section R.1.a.1).
 - b. Record each quarter the following information for the stationary source:

- 1) The total volume of make up solvent used, itemized by each solvent's chemical or manufacturer's product name. If the solvent is a mix of materials blended by the operator, the mix ratio by each solvent's chemical or manufacturer's product name shall be recorded. On a monthly basis, the total monthly volume (gallons) usage and reactive organic compound content (grams per liter or pounds per gallon of reactive organic compound) for each material listed in response to Section R.1.a.1).
- 2) The date Records confirming compliance with the acceptable disposal methods <u>listed in Section D.1</u>, each time waste solvent or waste solvent residue is removed from the <u>facility</u>-stationary source for disposal.
- 3) For solvent cleaning, the type of cleaning activity for each solvent used at the stationary source in accordance with the cleaning categories specified in Table 1 of this rule.
- 4) For each solvent cleaning machine:
 - i. Type of solvent cleaning machine.
 - ii. Brand name of each solvent used in the solvent cleaning machine and the reactive organic compound content of each solvent, as used.
 - iii. The solvent(s) initial boiling point.
- 5) When the solvent used is a mixture of different materials that are blended by the operator, the mix ratio of the batch shall be recorded and the reactive organic compound content of the batch shall be calculated and recorded in order to determine compliance with the specified limits of reactive organic compound content, as applied.
- If using an emission control system pursuant to Rule 321 Section M-N as a means of complying with this rule, the person shall maintain such records as required by the Operation and Maintenance Plan in Section O-Q on a daily basis. Key operating parameters and other information necessary to verify compliance with the required overall efficiency of the total system, as specified in Section N.1, shall be recorded. These parameters shall include, but not be limited to:
 - 1) Hours of operation;
 - 2) All maintenance work that requires the emission control system to be shut down;
 - 3) All information needed to demonstrate continuous compliance with Section N, such as temperatures, pressures, and/or flow rates.
- 2. Any person claiming an exemption from Rule 321, pursuant to Section B.2.b, shall record each quarter the following information for the stationary source: the aggregate evaporative surface area of all solvent cleaners subject to the Rule 321 Section B.2.b exemption claim. [Link to Note No. 70]
- <u>32.</u> In addition to the records required by Section R.1, any person claiming the Section B.9 exemption or the Section B.15 exemption, shall maintain records in order to demonstrate compliance with the solvent usage rate aggregate limits. For Section B.9 exemption claims, daily records on a facility basis shall be maintained. For Section B.15 exemption claims, monthly and calendar year total records on a stationary source basis shall be maintained.

3. <u>Maintain the Rrecords kept pursuant to this section rule shall be maintained on site for at least 2-3</u> years. Thereafter, the records shall be maintained such records either on site or readily available for expeditious inspection and review for an additional 3-2 years.

QS. Reporting Requirements

Any person holding a permit for a solvent eleaner cleaning machine or solvent cleaning subject to the requirements of this rule shall submit an annual report to the Control-District. At a minimum, The annual report shall contain the quarterly monthly records required by Rule 321-Section PR.1.b.1), the annual totals based on each of the solvent's monthly data, the name and address of the Permittee, and the Permit to Operate number that the solvent cleaning machine and/or solvent cleaning is subject to. The report shall be due March 1 for the previous calendar year.

RT. Compliance Schedule

Any person who owns, operates, or uses any solvent cleaning machine or performs any solvent cleaning subject to this rule shall meet the following compliance schedule:

1. New solvent cleaning machines and solvent cleaning operations:

Commencing [date of revised rule adoption], any new solvent cleaning machine shall comply with this rule the first time it is operated in the District. Also commencing [date of revised rule adoption], any new solvent cleaning shall comply with this rule the first time it is performed in the District. [Link to Note No. 71]

- 2. Existing solvent cleaning machines:
 - a. For any solvent cleaning machine previously subject to the Rule 321 adopted on September 18, 1997, commencing [date of revised rule adoption], the owner or operator shall ensure that the equipment complies with the applicable provisions of Rule 321. The provisions in Sections H.7, I.7, J.8, J.11, K.6, L.9, and L.11 have an effective date of [one year from the date of revised rule adoption]. [Link to Note No. 72]
 - b. For any solvent cleaning machine previously exempt from the September 18, 1997

 amended Rule 321 that lost its exemption by the adoption of amended Rules 102

 (Definitions), 202 (Exemptions to Rule 201), and/or Rule 321 on [date of revised rule adoption], the owner or operator of such equipment shall comply with the following:

 [Link to Note No. 73]
- 1. The owner or operator of any solvent cleaning equipment in operation as of July 17, 1997 and subject to the requirements of this rule shall comply with the following:
 - a. 1) By August 16, 1997[30 days from the date of revised rule adoption], be in full compliance with the applicable operating requirements of Rule 321 Sections D, E, and F.
 - b. 2) By January 13, 1998[180 days from the date of revised rule adoption], be in full compliance with the applicable recordkeeping and reporting provisions of Rule 321-Sections P-R and OS.
 - e. 3) By July 17, 1998[365 days from the date of revised rule adoption], be in full compliance with the applicable equipment requirements of Rule 321 Sections G, H, I, J. K, L, and MN.

- d. 4) Notwithstanding Rule 321 Section R.1.e, the provisions of Section G.8 shall take effect on July 17, 1997. Any lip exhaust installed after [date of revised rule adoption] shall be vented to an emission control system that meets the requirements of Section N at the time of installation, notwithstanding the dates in Sections G.8 and T.2.b.3. [Link to Note No. 74]
- This rule applies to any new or modified solvent cleaning equipment on July 17, 1997.
- 3. Existing solvent cleaning operations: [Link to Note No. 75]

The owner or operator of any facility performing solvent cleaning as of [date of revised rule adoption] and subject to the requirements of this rule shall comply with the following:

- a. By [30 days from the date of revised rule adoption], be in full compliance with the applicable operating requirements of Section D.
- b. By [180 days from the date of revised rule adoption], be in full compliance with the applicable recordkeeping and reporting provisions of Sections R and S.
- c. By [365 days from the date of revised rule adoption], be in full compliance with the solvent cleaning requirements of Rule Section M.

NOTE No.	PROPOSED AMENDED RULE 321 SECTION	PROPOSED AMENDED RULE (PAR) 321 NOTES	LINK TO RETURN TO PAR 321 ^a	APPENDIX F PAGE NO. FOR THE PAR 321 SECTION
1	Rule Title	The <i>solvent cleaning machines</i> term is from 40 CFR, Part 63, Subpart T. The <i>solvent cleaning</i> term is modeled on the term in the San Joaquin Valley Unified APCD (SJV) Rule 4663. "Solvent cleaning" is generally defined as those solvent activities, operations, and processes that occur outside of a solvent cleaning machine (SCM). The proposed amended Rule 102 contains definitions for <i>solvent, solvent cleaning</i> , and <i>solvent cleaning machine</i> .	Click here.	Page F-1
2	A.	The APCD used the SJV Rule 4663 "Applicability" provision as a model for this section.	Click here.	Page F-1
3	B.1	The revised 321.B.1 text will make the use of a solvent containing two percent or less of the following materials exempt from the rule (except for the recordkeeping provisions): 1. reactive organic compounds and 2. toxic air contaminants. If either one is exceeded, then the exemption will not apply. The recordkeeping provisions are added to facilitate verification of exemption claims. If a solvent cleaning machine is using a hazardous air pollutant and is subject to the 40CFR Part 63 Subpart T requirements, the equipment will be exempt by Section B.5 (providing the equipment complies with the applicable federal requirements).	Click here.	Page F-1
4	Deleted B.2	To make the new/revised requirements applicable for solvent cleaning, small cold cleaning machines, and remote reservoir cleaning machines, the one gallon capacity and one square foot surface area exemptions need to be deleted. For additional information on this deletion, see the discussion in Appendix E, Page 2, under the 321.B exemptions, item 2. Click here to go to that section.	Click here.	Page F-1
5	Deleted B.3 and Revised B.2	The APCD is proposing to delete the existing B.3 text because it is unnecessary. The proposed amended Rule (PAR) 321 Section J.9 provision indicates that the requirements only apply to units with a surface area of 10.8 square feet or greater. The new text adds an architectural coating application equipment exemption. This exemption is necessary to standby itself (i.e., not be included with the B.6 provision) because Rule 323 does not currently have any requirements or exemptions on the cleaning of application equipment. The owners/operators that apply architectural coatings should easily comply with the 950 grams of ROC per liter limit. Thus, the requirement does not warrant recordkeeping provisions for compliance verification. The APCD modeled this exemption on the South Coast AQMD (SC) Rule 1171, Section (h)(2)(H), as adopted May 6, 2005.	Click here.	Page F-1

^a When using a computer to view this material, you may return to the PAR 321 text by clicking the "here" link in the table using the left mouse button.

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	RULE 321		TO PAR	FOR THE PAR
	SECTION		321 ^a	321 SECTION
6	Deleted B.4.a	The deletion of the wipe cleaning exemption is necessary for consistency with the new PAR 321	Click here.	Page F-1
		solvent cleaning provisions.		
7	B.3	The District updated the name of the ATCM.	Click here.	Pages F-1 and
				F-2
8	B.4	This revised text is modeled on the exemption in the SJV Rule 4663.4.2.	Click here.	Page F-2
9	Deleted B.4.d	The deletion of the spray gun cleaning exemption is necessary for consistency with the PAR 321.	Click here.	Page F-2
10	B.5	The APCD is proposing that the definition of <i>solvent</i> include any liquid containing an ROC or a	Click here.	Page F-2
		toxic air contaminant (TAC). All HAP solvents are TACs. The addition of the "notwithstanding		
		Section B.1" text in Rule 321.B.5 is to prevail over the Section B.1 exemption. Thus, a SCM		
		subject to and complying with 40 CFR, Part 63, Subpart T, is exempt irrespective that the unit uses a		
		cleaning agent that contains more than 2 percent solvent that is a TAC.		
11	B.5	The listing of the chemicals in this section is no longer necessary with the addition of the	Click here.	Page F-2
		halogenated hazardous air pollutant solvent definition in Rule 321.		
12	Deleted B.4.f	The PAR 321 has provisions that apply to these types of units (e.g., Section O requirements for	Click here.	Page F-2
		airless and air-tight solvent cleaning machines). Thus, the District needs to eliminate this		
		exemption.		
13	B.6	Exempting the solvent cleaning operations that are subject to other rules from Rule 321 is consistent	Click here.	Page F-2
		with the approach of putting the solvent cleaning requirements into each of the operation- or		
		equipment-specific rules. The SJV and VC solvent cleaning rules have similar exemptions.		
14	B.7	This exemption is the same one found in SJV Rule 4663 Section 4.1 and VC Rule 74.6 Section	Click here.	Page F-2
		E.1.c.		
15	B.8	The APCD modeled this exemption on provisions in the SJV Rule 4663 Sections 4.5.1 and 4.5.2,	Click here.	Page F-3
		the SC Rule 1171 Section (g)(3), and VC Rule 74.6 Sections E.2.c and d.		
16	B.8	The PAR 321.B.8.d provision stems from various exemptions in the SC Rule 1122 and the SJV	Click here.	Page F-3
		Rule 4662, the SBCAPCD responses to concerns from the regulated community, and the limits for		
		like categories in the Section M.1, Table 1. By making these solvent cleaning machines exempt		
		from the 50 grams per liter ROC limit, but limiting the solvent to 900 grams per liter of ROC,		
		should provide industry with an incentive to not switch from solvent cleaning to a solvent cleaning		
		machine to be subject to less stringent limits.		
17	B.9	Exemption B.9 is similar to the one found in SC Rule 1171(g)(4) and SJV Rule 4663.4.8. The	Click here.	Page F-3
		APCD added the recordkeeping provision to facilitate determinations of exemption applicability.		
		Also, in place of the reference to "CARB regulations" (as found in other air district rules) staff cited		
		the consumer product provisions (California Code of Regulations, Title 17, Section 94507 et seq.) to		
10	7.10	be more specific on the requirement.	GU 1 1	D 7.0
18	B.10	The APCD modeled this exemption on the SC Rule 1171 Section (h)(6)(B) as adopted on October 8,	Click <u>here</u> .	Page F-3
		1999 and SJV Rule 4663 Section 4.6 provisions.		

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19	B.11	The proposed new Section B.11.a and b exemptions are similar to the SC Rule 1171 Section	Click here.	Page F-3
		(g)(11)(A) and (B) provisions. Staff added the Section B.11.c exemption because gas-path cleaners		
		inject solvent into gas turbines or jet engines under pressure and there is likely atomization		
		occurring during the process.		
20	B.12	With the addition of the term <i>moisture</i> to the solvent cleaning definition (Rule 102), tarmac de-icing	Click here.	Page F-3
		operations become a subset of solvent cleaning. No air districts require control techniques for		
		aircraft de-icing. A feasibility study on controlling de-icing operations has not been performed.		
		Thus, the APCD prefers not to apply Rule 321 provisions to such operations at this time and is		
		adding this exemption.		
21	B.13	This exemption is similar to an exemption provided in the SJV Rule 4663 Section 5.1.6 (adopted	Click here.	Page F-3
		December 20, 2001). The SJV staff added this exemption in response to an industry concern about		
		prohibiting the use of "Hudson" type sprayers, which are hand-pump pressurized containers with		
		atomizing spray nozzles.		
22	B.14	The District is adding this exemption to clarify that the Rule 321 solvent cleaning requirements do	Click <u>here</u> .	Pages F-3 and
		not apply to such sources.		F-4
23	B.15	This exemption is similar to the one found in the SJV Rule 4663 Section 4.4.	Click here.	Page F-4
24	B.16.a - f	Exemptions B.16.a - f stem from similar provisions found in the SC Rule 1171(g) and the VC Rule	Click <u>here</u> .	Page F-4
		74.6.E.2.		
25	B.16.g	The APCD added this exemption to allow offshore platform operators to use mineral spirits to	Click here.	Page F-4
		remove crude oil residues. Limiting the solvent's composite partial pressure to 8 mm of Hg at 20		
		degrees Celsius or less is consistent with the EPA guidance in the document titled, "Control		
		Techniques Guidelines: Industrial Cleaning Solvents," September 2006 (EPA-HQ-OAR-2006-		
		0535). Mineral spirits meet the composite partial pressure limit and the 800 grams per liter ROC		
		content limit.		
26	B.17	These exemptions are similar to the VC Rule 74.6, Section E.2.m and n exemptions.	Click here.	Page F-4
27	B.18	This exemption is similar to the VC Rule 74.6.1, Section G.3 exemption.	Click here.	Page F-4
28	B.19	The APCD modeled this exemption on the VC Rule 74.6.E.1.h text.	Click here.	Page F-4

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29	B.20	This is a limited exemption from several new vapor cleaning machine requirements. Equipment	Click <u>here</u> .	Page F-5
		subject to this exemption will not be required to have an automated parts handling system, an		
		enhanced freeboard refrigeration device, a superheated vapor zone, or a freeboard ratio of 1.0.		
		The APCD is proposing this exemption to provide relief for several existing uncontrolled vapor		
		cleaners used by Raytheon to clean electronic components. Raytheon indicates it has explored using		
		other equipment (e.g., airless and air-tight systems) but has not been able to find suitable		
		replacements. The SC Rule 1122 (E) provides a narrow and unique exemption for specific parts		
		cleaning operations, which is similar to the approach the District is taking.		
		The proposed maximum ROC limit of 188 pounds per month per stationary source is based on data		
		provided by Raytheon and may not represent the equipment's maximum potential to emit. The		
		District is proposing the qualifying provisions of this exemption, including the pounds per month		
		per stationary source limit, as a means to develop an exemption that will be acceptable to Raytheon,		
		the APCD, ARB, and EPA.		
30	B.21	This is an exemption that is unique to SBC. The District is aware that medical device manufacturers	Click <u>here</u> .	Page F-5
		sometime leak test devices using a solvent bath. This limited exemption would allow the practice to		
		continue without subjecting the solvent wash stations to the rule's minimum freeboard height and/or		
21	D 22	free ratio requirements, or alternative compliance methods (water cover or emission control system).	Cli ala la ana	Dans E.f.
31	B.22	The APCD is adding this exemption to clarify that metal lift-off operations and the other specifically listed operations are not subject to the Rule 321 requirements. (These wipe cleaning operations are	Click here.	Page F-5
		currently exempt from Rule 321.) Members of the regulated community indicated that they need to		
		use n-methyl-2-pyrrolidone (NMP) for these specific operations. Further, that they have searched		
		for but have not been able to find suitable replacement solvents that meet their cleanliness demands.		
		Although NMP has a high-ROC content (1,027 g/l) it has an extremely low composite partial		
		pressure (0.29 mm Hg at 20 °C), which tends to reduce the evaporation rate and emissions.		
32	B.23	This exemption stems from a request from a manufacturer. The company has a small sump that the	Click here.	Page F-5
		operator lifts out of the SCM and empties by pouring the solvent directly into the bulk container.		
		The District agreed that for the small volume of solvent transferred (about 2 - 3 gallons) an		
		alternative method involving siphoning solvent would not likely achieve a significantly lower		
		emission rate. Thus, the District is adding this exemption.		
33	B.24	The District is providing this specific exemption in response to a request from Raytheon for a	Click <u>here</u> .	Page F-5
		limited waiver from the requirement to have a freeboard ratio of 1.0.		

NOTE	PROPOSED	PROPOSED AMENDED RULE (PAR) 321 NOTES	LINK TO	APPENDIX F
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34	C (Section Title: Definitions)	 In general, the solvent cleaning machine terms used herein have the same meaning as those found in 40 CFR, Part 63, Subpart T - National Emission Standards for Halogenated Solvent Cleaning (40 CFR §63.460 et seq.). The basis for using the definitions from the federal statute is that: 1. It is the most global regulatory document available relative to solvent cleaning machine requirements, and 2. EPA and manufacturers worked together to develop the terms, and 3. They are available on the Internet (http://www.gpoaccess.gov/cfr/retrieve.html, under Title "40," CFR "63," Section "461"). 	Click here.	Page F-5
35	C (Airless and Air-Tight SCM Definition)	The APCD modeled the <i>solvent cleaning</i> terms and definitions on those used by other air districts. These definitions are the same ones found in SJV Rule 4662. PAR 321, Section O, provides an alternative compliance method to Sections E through L involving the use of either an airless or airtight solvent cleaning machine.	Click <u>here</u> .	Page F-5
36	C (Deleted Control Device Definition)	The APCD changed the term to <i>emission control device</i> and relocated it so that it would be in alphabetical order. The PAR 321 uses the 40 CFR, Part 63, Subpart T, <i>control device</i> term when describing a <i>vapor level control device</i> . PAR 321 also uses the term <i>control device</i> when establishing requirements for the emission controls. Thus, it is necessary to differentiate between these two uses of the term <i>control device</i> .	Click here.	Page F-7
37	C (Conveyorized [In-Line or Continuous] Cleaning Machine Definition)	40 CFR, Part 63, Subpart T, provisions do not use the term <i>conveyorized</i> . For congruency with the SC and SJV degreasing rules, the conveyorized term is being retained. The addition of <i>web</i> is provided for consistency with the <i>continuous web cleaning machine</i> definition. The terms <i>gyro</i> and <i>cross-rod</i> cleaning machines are being deleted because these are loaded manually or semi-continuously, which makes them batch cleaning machines.	Click here.	Page F-7
38	C (Deleted Degreaser Definition)	The APCD is revising the <i>degreaser</i> definitions to be consistent with 40 CFR, Part 63, Subpart T, wherever possible. The federal regulation does not define <i>degreaser</i> and does not use the term. Instead, 40 CFR, Part 63, Subpart T, uses <i>solvent cleaning machine</i> . Therefore, staff replaced the term <i>degreaser</i> with <i>solvent cleaning machine</i> throughout Rule 321 and deleted the definition of <i>degreaser</i> from Section C. Rule 102 includes a definition of <i>degreaser</i> to clarify that degreaser has the same meaning as <i>solvent cleaning machine</i> .	Click here.	Page F-7
39	C (Electronic Components Definition)	The District deviated from similar definitions found in the SC, SJV, and VC rules. The proposed definition is intended to be more descriptive and incorporates <i>semiconductor</i> terms. The APCD is not planning to have a separate <i>semiconductor manufacturing</i> rule as is done in SC and VC.	Click here.	Page F-8

^a There is one exception. The 40 CFR, Part 63, Subpart T, Section 63.461 uses the term *degreaser* in the definition of *batch cleaning machine*. Table of Annotations for

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40	C (Deleted	Evaporative surface area has been replaced by the 40 CFR, Part 63, Subpart T, solvent/air interface	Click here.	Page F-8
	Evaporative	area term.		
	Surface Area			
	Definition)			
41	C (Gas-Path	Staff used the San Diego County APCD (SD) Rule 67.6(c)(8) "gas-path cleaning machine" as a	Click here.	Page F-9
	Solvent Cleaner	model for the proposed revised definition. For rule clarity, staff recommends that the current		
	Definition)	"liquid-path" portion of the term be deleted. The PAR 321, Section M.2.c, includes <i>solvent flow</i> and		
		solvent flush methods as acceptable cleaning techniques for solvent cleaning. Without the deletion		
		of "liquid-path" there could be confusion between the solvent cleaning and gas/liquid-path solvent		
		cleaner requirements. Thus, the "liquid-path" description is removed from the term and the		
		proposed amended Section F operating requirements apply only to gas-path solvent cleaners.		
42	C (High	A high volatility solvent includes any solvent with an initial boiling point (IBP):	Click here.	Page F-10
	Volatility	4		
	Solvent	1. ≤ 248 °F or		
	Definition)	2. > 248 °F, but the in-use temperature is not ≤ 212 °F below the solvent's IBP.		
		The Rule 202.U.2.b uses a solvent IBP temperature exemption applicability threshold of 302 °F or		
		greater. For a remote reservoir SCM employing turpentine (IBP = 302 °F) used in an environment		
		without air conditioning, the ambient and in-use temperature could be expected to reach 90 °F or		
		greater. Such a unit would be exempt from permit, but would need to comply with the Rule 321		
		Section H.5 0.75 freeboard ratio requirement because the solvent would be classified as a <i>high</i>		
		volatility solvent.		
43	C (In-Line	The revised definition is from 40 CFR, Part 63, Subpart T. A mechanized solvent cleaning machine	Click here.	Page F-9
	Cleaning	is an <i>in-line</i> or <i>continuous cleaning machine</i> only if it uses an automated parts handling system to		
	Machine or	provide a continuous supply of parts. If a cleaner is loaded manually or semi-continuously, it is not		
	Continuous	an in-line cleaning machine or a continuous solvent cleaning machine. Gyro (Ferris wheel) and		
	Cleaning	cross rod cleaning machines are not in-line or continuous cleaning machines because the parts being		
	Machine	cleaned are loaded manually or semi-continuously.		
	Definition)			
44	C (Low	The definition stems from the ARB RACT/BARCT document. However, the APCD discovered that	Click here.	Page F-10
	Volatility	the definition had an error (100 degrees Celsius equals 212 degrees Fahrenheit, not 180 degrees		
	Solvent	Fahrenheit). Thus, the revised definition takes into account the correct Fahrenheit temperature for		
	Definition)	deeming a solvent a low volatility solvent.		

NOTE	PROPOSED	PROPOSED AMENDED RULE (PAR) 321 NOTES	LINK TO	APPENDIX F
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	RULE 321		TO PAR	FOR THE PAR
	SECTION		321 ^a	321 SECTION
45	C (Solvent/Air	These definitions are generally consistent with the definitions found in 40 CFR, Part 63, Subpart T.	Click here.	Page F-12
	Interface and	Solvent/air interface replaces the current air-solvent interface and air-vapor interface terms. The		
	Solvent/Air	solvent/air interface term appears in the definitions of freeboard area and freeboard height.		
	Interface Area	Solvent/air interface area replaces the current evaporative surface area term. The solvent/air		
	Definitions)	interface area term appears in various Rule 321 operation and equipment requirements.		
		The District added the text on the area being the drain area for remote reservoir cleaners at the request of the regulated community and for consistency with the earlier <i>evaporative surface area</i> definition.		
46	C (Deleted Solvent Cleaning Definition)	The <i>solvent cleaning</i> term has been moved to Rule 102 and it is being modified to take on a different meaning. Basically, <i>solvent cleaning</i> includes any operation using a solvent performed outside of a solvent cleaning machine. This approach is consistent with the one used in the SJV Rule 4663.	Click here.	Page F-12
47	D	In general, the APCD added "owns, operates, or uses" to sections on applicability and rule	Click here.	Page F-13
1		requirements to improve rule clarity. This terminology is being added in numerous places	CHER HOTE.	1 age 1 13
		throughout the revised rule. For the sake of brevity, the notes in this annotated draft PAR 321 will		
		not re-iterate the addition of the "owns, operates, or uses" text.		
48	D.10 - D.12	Requirements in PAR321.D.10 and 11 are similar to those found in 40 CFR, Part 63, Subpart T, and	Click here.	Page F-15
		SC Rule 1122. The intent is to ensure that good housekeeping procedures are followed. The		
		Section D.12 provision is modeled on language from SC Rule 1122(c)(1)(E).		
49	D.13	The APCD moved this provision from Rule 321, Section G.10. A similar provision is found in the	Click here.	Page F-15
		SC Rule 1122, Section (c)(1)(K), Work Practice Requirements.		
50	H.7	Limiting the solvent's ROC content will likely affect the type of solvent used in remote reservoir	Click here.	Page F-18
		cleaners (e.g., Safety Kleen units) in shops such as automobile repair shops. Limiting remote		
		reservoir cleaner solvent ROC content is consistent with the approach taken by SJV, SC, and VC.		
		The 50 grams of ROC per liter limit is based on the limit specified in the SC Rule 1122, adopted July 11, 1997.		
51	I	If a remote reservoir cold cleaning machine has an enclosed container that is accessible for dipping	Click here.	Page F-18
		or soaking parts, such machine is subject to the provisions in Section I. (See the definition of		8-
		"Remote Reservoir Cleaning Machine," page F-11, or click here, for the text on remote reservoir		
		cold cleaners that are designed to allow dip or soak cleaning are considered to be batch cold		
		cleaning machines.)		
52	I.7	The 50 grams of ROC per liter limit is based on the limit specified in the SC Rule 1122, adopted	Click here.	Page F-19
		July 11, 1997.		

NOTE No.	PROPOSED AMENDED	PROPOSED AMENDED RULE (PAR) 321 NOTES	LINK TO RETURN	APPENDIX F PAGE NO.
NO.	RULE 321 SECTION		TO PAR	FOR THE PAR 321 SECTION
53	J.11	The APCD modeled the Section J.11 requirements on provisions in: 1. The SJV Rule 4662, Sections 5.4.10.7 - 5.4.10.12; and 2. The SC Rule 1122, Section (e)(1)(B).	Click here.	Page F-20
54	K.6	The 50 grams of ROC per liter limit is based on the limit specified in the SC Rule 1122, adopted July 11, 1997.	Click here.	Page F-20
55	L.11	The APCD modeled the Section L.11 requirements on provisions in: 1. The SJV Rule 4662, Sections 5.5.7.7 - 5.5.7.12; and 2. The SC Rule 1122, Section (e)(2)(C).	Click here.	Page F-22
56	М	In general, the proposed new Section M provisions are modeled on requirements in the SC Rule 1171, Solvent Cleaning Operations; the SJV Rule 4663, Organic Solvent Cleaning, Storage, and Disposal; and the VC Rule 74.6.		Page F-22
57	M.1, Table 1, Category (a)(i) & Category (b)(i)	These limits are based on those limits in the SJV Rule 4663 (effective November 15, 2003)		Page F-23
58	M.1, Table 1, Categories (a)(ii), (a)(iii), (b)(ii), (b)(iii), and (c)	The APCD based these limits on the limits in the SJV Rule 4663 (effective November 15, 2002 through November 14, 2003).		Page F-23
59	M.1, Table 1, Categories (a)(iv) and (b)(iv)	Table 1, The silicone manufacturing limits were added in response to comments by a member of the regulated community.		Page F-23
60	M.1, Table 1, Category (d)	The District based the limit on comments from the regulated community and the Vandenberg Air Force Base practice of using IPA for cleaning fuel transfer lines.	Click here.	Page F-23
61	M.2	These provisions on cleaning devices and methods are similar to requirements found in SC Rule 1171, Section (c)(2); SJV Rule 4663, Section 5.2.5; and VC Rule 74.6, Section B.2.		Page F-24
62	M.3	The proposed new 321.M.3 provisions are modeled on the provisions in SJV Rule 4663, Section 5.2.7. The Section M, Table 1 category (c) allows the solvent used for cleaning application equipment to have an ROC content up to 950 grams per liter. However, under the Section M.3 provision, an enclosed system (or other APCO-approved equipment) is needed if the solvent's ROC content exceeds 50 grams per liter.	Click here.	Page F-24

NOTE	PROPOSED	PROPOSED AMENDED RULE (PAR) 321 NOTES	LINK TO	APPENDIX F
No.	AMENDED		RETURN	PAGE NO.
	RULE 321		TO PAR	FOR THE PAR
	SECTION		321 ^a	321 SECTION
63	N	Section D.9 (solvent atomization), Section G.8 (lip exhausts installed after July 17, 1997), and	Click here.	Page F-24
		proposed amended Rule 321 Section T.2.b.4) (lip exhausts installed on previously exempt SCMs		
		after the rule adoption date) require the use of an emission control system that complies with		
		Section N.		
		Many other sections allow the use of an emission control system that complies with Section N as an		
		alternative compliance method. Instead of listing those rule sections in the rule, the APCD elected		
		to simply indicate or as an alternative compliance method as provided for in this rule.		
		The PAR 321 Sections that provide for use of an emission control system as an alternative		
		compliance method include: H.7, I.7, J.11, K.6, L.11, and M.1		
64	N.1	The District added and toxic air contaminant emissions to Section N.1 to cover cases where a source	Click here.	Page F-24
		is using a liquid containing a toxic air contaminant and wants to use an emission control system as		
		an alternative compliance method.		
65	N.5	The new Section N.5 provision on a deadline for completing an initial source test is being added to	Click <u>here</u> .	Page F-24
		ensure that sources complete such a test in a timely manner		
66	N.6	This requirement is similar to the provision found in SJV Rule 4663, Section 5.5.5. It is an	Click here.	Page F-24
		overarching provision that prohibits use of an emission control system unless the ROC emission rate		
		from such system is equal to or less than the emissions otherwise expected with the use of a		
		complying solvent. The provision prevents a source from using a large quantity of high-ROC		
		content solvent with an emission control system unless the control system's overall efficiency is		
		such that it achieves a lower emission rate than the one that would have been achieved through use		
		of a complying solvent. Theoretically, this provision may require that a system's overall control		
	0	efficiency be above the 85% requirement in Section N.1 to comply with Section N.6.	Cli ala la ana	Dans E 25
67	О	The SC Rule 1122 and SJV Rule 4662 allow use of air-tight cleaning systems and airless cleaning systems. These systems are state-of-the-art machines that have low emissions.	Click <u>here</u> .	Page F-25
68	P.5	To provide additional options, the APCD recommends the addition of these two test methods:	Click here.	Page F-26
08	r.3	10 provide additional options, the AFCD recommends the addition of these two test methods.	CHCK <u>Here</u> .	rage r-20
		1. EPA Test Appendix A-1, Method 2F, Determination of Stack Gas Velocity and Volumetric		
		Flow Rate with Three-Dimensional Probes, and		
		Tion Take with Three Dimensional Floods, and		
		2. EPA Test Appendix A-2, Method 2G, Determination of Stack Gas Velocity and Volumetric		
		Flow Rate with Two-Dimensional Probes.		
69	Q	The deleted text should no longer be necessary as sources should have already obtained the APCO	Click here.	Page F-26
	`	approval for their Operation and Maintenance Plans.		6-

NOTE No.	PROPOSED AMENDED RULE 321 SECTION	PROPOSED AMENDED RULE (PAR) 321 NOTES	LINK TO RETURN TO PAR 321 ^a	APPENDIX F PAGE NO. FOR THE PAR 321 SECTION
70	Deleted P.2.	The APCD is eliminating the <i>small surface area exemption</i> (Rule 321.B.2.b). Thus, the recordkeeping provision associated with this exemption is no longer needed.	Click <u>here</u> .	Page F-27
71	T.1	When the APCD indicates that qualifying SCMs or solvent cleaning <i>shall comply with the rule the first time it is operated or performed in the District,</i> it should be recognized that the provisions in Sections H.7, I.7, J.8, J.11, K.6, L.9, and L.11 have an effective date of one year from the date of revised rule adoption. Thus, the District does not require new equipment or solvent cleaning operations to comply with those rule provisions before the section's effective date.	Click here.	Page F-28
72	T.2.a	The owners and operators of existing solvent machines previously subject to Rule 321 are required to maintain continuous compliance when the newly adopted revised rule supersedes the Rule 321 adopted on September 18, 1997.	Click here.	Page F-28
73	T.2.b	Changes to Rules 102, 202, and 321 may cause some previously exempt solvent cleaning machines to become subject to Rule 321 for the first time. For example, an unheated solvent rinsing container having a capacity of 9 gallons and designed to operate in a closed system fashion is presently exempt by Rule 202.U.1 and Rule 321.B.4.f. However, under the revised rules, such a unit will no longer be exempt. The APCD is proposing incremental, phased compliance periods for such units that follow the present rule compliance periods.	Click here.	Page F-28
74	T.2.b.4)	The APCD is revising this section to indicate that any lip exhaust installed after the adoption of the revised rule will need to be vented to an emission control system at the time of its installation.	Click <u>here</u> .	Page F-29
75	T.3	The adoption of the revised Rule 321 will eliminate the solvent cleaning (wipe cleaning) exemption in Section B.4.a. In general, all existing qualifying solvent cleaning operations are becoming subject to Rule 321 for the first time via the proposed amended rule adoption. The District is providing incremental, phased compliance periods for solvent cleaning similar to those in the existing rule (adopted July 17, 1997).	Click here.	Page F-29

Click <u>here</u> to return to the list of Appendices in the Background Paper.

Appendix G Summarized Data on Emission Reductions, Emissions, and Cost-Effectiveness

Table 1. PROJECTED EMISSION REDUCTIONS FOR CALENDAR YEAR 2011^a Reactive Organic Compounds in Tons per Year (Tons per Day)

					Projected	CY 2011	CY 2011
		Facility or			CY 2011	Emissions	Emission
Item	Company/Facility or Area	EIC	Device	Category ^b	Emissions,	After Control,	Reductions,
Ite	Source Category	Number	No.	Category	tons per year	tons per year	tons per year
		Number			(tons per	(tons per	(tons per
					day)	day) ^c	day) ^c
1	Bardex Corporation	01152	108834	SCM	0.12	0.03	0.09
					(0.00033)	(0.00009)	(0.00024)
2	Celite Corporation	00012	008043	SC	0.15	0.15	0.01
					(0.00042)	(0.00040)	(0.00002)
3	Celite Corporation	00012	008043	SCM	0.04	0.01	0.09
					(0.00010)	(0.00003)	(0.00024)
4	DCOR, LLC., Platform A	08003	004883	SC	0.44	0.42	0.02
					(0.00120)	(0.00116)	(0.00005)
5	DCOR, LLC., Platform A	08003	004883	SCM	0.11	0.03	0.08
					(0.00030)	(0.00008)	(0.00022)
6	DCOR, LLC., Platform B	08004	004901	SC	1.09	1.04	0.04
					(0.00298)	(0.00286)	(0.00012)
7	DCOR, LLC., Platform B	08004	004901	SCM	0.27	0.08	0.20
	, ,				(0.00074)	(0.00021)	(0.00054)
8	DCOR, LLC., Platform C	08006	004935	SC	1.28	1.23	0.05
	, ,				(0.00351)	(0.00337)	(0.00014)
9	DCOR, LLC., Platform C	08006	004935	SCM	0.32	0.09	0.23
	, ,				(0.00088)	(0.00024)	(0.00063)
10	DCOR, LLC., Platform	08012	005483	SCM	0.01	0.00	0.01
	Habitat				(0.00002)	(0.00001)	(0.00002)
11	DCOR, LLC., Platform	08007	004953	SC	1.14	1.10	0.05
	Henry			~ ~	(0.00313)	(0.00301)	(0.00013)
12	DCOR, LLC., Platform	08007	004953	SCM	0.29	0.08	0.21
	Henry		30.723	201.1	(0.00078)	(0.00022)	(0.00057)
13	DCOR, LLC., Platform	08005	004920	SC	4.83	4.64	0.19
	Hillhouse	00000	00.720	20	(0.01323)	(0.01270)	(0.00053)
14	DCOR, LLC., Platform	08005	004920	SCM	1.21	0.33	0.87
17	Hillhouse	00003	001720	50111	(0.00331)	(0.00092)	(0.00239)
15	ExxonMobil Production	08018	005345	SCM	0.03	0.01	0.02
13	Company, Platform	00010	003343	SCIVI	(0.00007)	(0.00002)	(0.00005)
	Harmony				(0.00007)	(0.0002)	(0.00003)
16	Greka Oil & Gas, Inc., Bell	03211	005957	SC	0.90	0.25	0.65
	Lease (Cat Canyon)		,.,		(0.00245)	(0.00068)	(0.00177)
	······································		l		(/=/	((= = = = /

^a The data shown in this table represents calendar year 2011 figures. The District used data from the 2007 emission inventory and applied activity (growth), compliance efficiency, and control factors.

b Solvent Cleaning Machine (SCM), Solvent Cleaning (SC), or Area Source (AS) categories.

^c Includes the effect of having an 80 percent compliance efficiency.

			1		D ' . 1	CV 2011	CV 2011
					Projected	CY 2011	CY 2011
	G 75 314 A	Facility or	ъ.		CY 2011	Emissions	Emission
Item	Company/Facility or Area	EIĆ	Device	Category ^b	Emissions,	After Control,	Reductions,
I	Source Category	Number	No.		tons per year	tons per year	tons per year
					(tons per	(tons per	(tons per
					day)	day) ^c	day) ^c
17	Greka Oil & Gas, Inc.,	03303	005962	SC	0.16	0.04	0.11
	Morganti Lease				(0.00043)	(0.00012)	(0.00031)
18	Greka Oil & Gas, Inc.,	03948	007263	SC	0.01	0.00	0.01
	Righetti Lease				(0.00004)	(0.00001)	(0.00003)
19	Helix Medical, LLC.	04487	107500	SC	3.49	3.35	0.14
					(0.00957)	(0.00919)	(0.00038)
20	Indigo Systems Corporation	09745	107595	SC	0.79	0.76	0.03
					(0.00217)	(0.00208)	(0.00009)
21	Innovative Micro	10867	109942	SC	1.42	1.36	0.06
	Technology, Inc. (IMT)				(0.00388)	(0.00373)	(0.00016)
22	Innovative Micro	10867	110204	SC	0.17	0.17	0.01
	Technology, Inc. (IMT)				(0.00048)	(0.00046)	(0.00002)
23	International Transducer	01634	107650	SC	1.07	1.03	0.04
	Co.				(0.00293)	(0.00281)	(0.00012)
24	Lockheed Martin Missiles	09424	009932	SC	0.43	0.41	0.02
- '	& Fire Control, SB	٠, ١٠.	00//02	20	(0.00118)	(0.00113)	(0.00005)
	Focalplane				(0.00110)	(0.00112)	(0.00000)
25	Lockheed Martin Missiles	09424	010049	SC	1.17	1.13	0.05
23	& Fire Control, SB	07121	010015	S.C	(0.00322)	(0.00309)	(0.00013)
	Focalplane				(0.00322)	(0.00307)	(0.00013)
26	Lockheed Martin Missiles	09424	010050	SC	0.65	0.63	0.03
20	& Fire Control, SB	03424	010030	SC	(0.00179)	(0.00172)	(0.00007)
	Focalplane				(0.00179)	(0.00172)	(0.00007)
27	Medtronic PS Medical	04635	107596	SC	4.66	4.47	0.19
21	Meditolic FS Medical	04033	107390	SC	(0.01277)	(0.01225)	(0.00051)
20	NT-d'1 A d' 0	06100	111202	g.C.			
28	National Aeronautics &	06100	111283	SC	0.15	0.15	0.01
	Space Admin., VAFB,				(0.00042)	(0.00040)	(0.00002)
20	Solvent Usage (SLC-2)	00061	001256	ng	1.12	1.00	0.04
29	NuSil Technology	02361	001356	SC	1.12	1.08	0.04
					(0.00308)	(0.00295)	(0.00012)
30	NuSil Technology	02361	006026	SC	0.42	0.40	0.02
					(0.00115)	(0.00111)	(0.00005)
31	NuSil Technology, Silicone	04621	006001	SC	4.19	4.02	0.17
	Technology				(0.01148)	(0.01102)	(0.00046)
32	Pacific Scientific, EKD	08934	107600	SC	0.29	0.28	0.01
1	,				(0.00081)	(0.00077)	(0.00003)
33	Plains Exploration &	03095	008759	SC	0.03	0.01	0.02
	Production Company,	03073	000107		(0.00007)	(0.00002)	(0.00005)
1	Lompoc Oil and Gas Plant				(0.00007)	(0.00002)	(0.00005)
34	Plains Exploration &	08016	005459	SC	0.32	0.31	0.01
J+	Production Company,	00010	005755	50	(0.00089)	(0.00085)	(0.00004)
	Platform Irene				(0.00009)	(0.00003)	(0.00004)
35	Plains Exploration &	08016	005459	SCM	0.08	0.02	0.06
33		00010	003439	SCIVI	(0.00022)	(0.0006)	(0.00016)
	Production Company, Platform Irene				(0.00022)	(0.00000)	(0.00010)
26		01071	005161	S.C.	1.02	0.98	0.04
36	Raytheon Space &	01971	005161	SC			
	Airborne Systems		<u> </u>		(0.00279)	(0.00268)	(0.00011)

		ı	r			~~~	ATT # 0.1.1
					Projected	CY 2011	CY 2011
		Facility or			CY 2011	Emissions	Emission
Item	Company/Facility or Area	EIC	Device	Category ^b	Emissions,	After Control,	Reductions,
Ite	Source Category	Number	No.	Category	tons per year	tons per year	tons per year
		Number			(tons per	(tons per	(tons per
					day)	day) ^c	day) ^c
37	Raytheon Space &	01971	005163	SC	0.28	0.27	0.01
	Airborne Systems				(0.00077)	(0.00074)	(0.00003)
38	Raytheon Space &	01971	108489	SC	0.12	0.11	0.00
30	Airborne Systems	01571	100107	50	(0.00032)	(0.00031)	(0.00001)
39	Raytheon Space &	03890	005234	SC	1.07	1.02	0.04
	Airborne Systems	03070	003234	50	(0.00292)	(0.00280)	(0.00012)
40	Raytheon Space &	04140	107601	SC	1.28	1.25	0.03
10	Airborne Systems	01110	107001	50	(0.00350)	(0.00341)	(0.00009)
41	Raytheon Space &	08742	109000	SC	0.58	0.56	0.02
71	Airborne Systems	00742	10,000	БС	(0.00159)	(0.00153)	(0.00006)
12	•	10341	107607	SC	, ,	0.24	, ,
42	Superconductor	10341	107607	SC	0.25		0.01
	Technologies, Inc.				(0.00067)	(0.00065)	(0.00003)
43	United States Air Force,	00201	007604	SC	1.92	1.84	0.08
	VAFB, Solvent Usage				(0.00526)	(0.00505)	(0.00021)
	(HAZMART)						
44	Venoco, Inc., Platform	03105	005883	SC	0.35	0.34	0.01
	Holly				(0.00096)	(0.00093)	(0.00004)
45	Degreasing-Cold Cleaning-	220-204-	N/A	AS	379.52	269.69	109.84
	Petroleum Naphtha:	0500-0000			(1.03979)	(0.73887)	(0.30092)
	General						
46	Degreasing-Cold Cleaning-	220-204-	N/A	AS	25.54	24.62	0.92
	Alcohols (Unspecified)	3022-0000			(0.06999)	(0.06745)	(0.00253)
47	Degreasing-Cold Cleaning-	220-204-	N/A	AS	14.60	10.37	4.22
	Terpenes (Unspecified)	3333-0000	- "		(0.03999)	(0.02842)	(0.01157)
48	Degreasing-Cold Cleaning-	220-204-	N/A	AS	69.34	49.23	20.11
70	Other/Not Classified:	8106-0000	11/14	Ab	(0.18996)	(0.13487)	(0.05509)
	Specify Degreasing	8100-0000			(0.16990)	(0.13467)	(0.03309)
49	Degreasing-Handwiping-	220-208-	N/A	AS	47.44	19.98	27.46
+7	Petroleum Naphtha	0500-0000	1 1/71	Дυ	(0.12997)	(0.05474)	(0.07523)
50	Degreasing-Handwiping-	220-208-	N/A	AS		, ,	
30	Alcohols (Unspecified)	3022-0000	IN/A	AS	58.39 (0.15997)	56.28 (0.15418)	2.11 (0.00579)
<u></u> 1	•		NT/A	A.G	, ,	` ′	` ,
51	Degreasing-Handwiping-	220-208-	N/A	AS	7.30	2.96	4.33
	Glycol Ethers (Unspecified)	3176-0000	,	. ~	(0.02000)	(0.00812)	(0.01188)
52	Degreasing-Handwiping-	220-208-	N/A	AS	43.79	27.90	15.89
	Ketones (Unspecified)	3204-0000			(0.11998)	(0.07643)	(0.04354)
53	Degreasing-Handwiping-	220-208-	N/A	AS	10.95	10.55	0.40
	Toluene/Xylene	3339-0000			(0.02999)	(0.02890)	(0.00110)
54	Degreasing-Handwiping-	220-208-	N/A	AS	3.65	2.72	0.92
	Degreasing Solvents-Pure	8104-0000			(0.01000)	(0.00746)	(0.00253)
	(Unspecified)						
55	Degreasing-Handwiping-	220-208-	N/A	AS	18.25	13.62	4.62
	Degreasing Solvents-	8106-0000			(0.04999)	(0.03732)	(0.01267)
L	Blends (Unspecified)						

		Facility or EIC Number	Device No.		Projected	CY 2011	CY 2011
Company/Facility or Area Source Category					CY 2011	Emissions	Emission
	Company/Facility or Area			Category ^b	Emissions,	After Control,	Reductions,
	Source Category			Category	tons per year	tons per year	tons per year
					(tons per	(tons per	(tons per
					day)	day) ^c	day) ^c
m . 1					718.49	523.64	194.91 ^a
	Totals					(1.43463)	(0.53399)

Table 2. EMISSION REDUCTION ESTIMATES FROM THE 2007 CLEAN AIR PLAN ANALYSIS VERSUS THE CURRENT DATA FOR REVISED RULE 321

Category	CY 2015 Projected Emission Reductions, tons per year (tons per day)	CY 2020 Projected Emission Reductions, tons per year (tons per day)					
Emissions Reductions per the 2007 Clo	ean Air Plan (Base Year: CY 2	002)					
ARB Area Source	274.28 (0.7515)						
Solvent Cleaning Machines (SCMs)	4.91 (0.0134)	4.90 (0.0134)					
Solvent Cleaning (SC)	8.89 (0.0244)	8.86 (0.0243)					
TOTAL	262.94 (0.7204)	288.04 (0.7891)					
Emissions Reductions per the 2009 Ru	llemaking Effort (Base Year: C	CY 2007)					
ARB Area Source	190.84 (0.5229)	190.84 (0.5229)					
Solvent Cleaning Machines (SCMs)	1.80 (0.0049)	1.80 (0.0049)					
Solvent Cleaning (SC)	2.17 (0.0059)	2.10 (0.0057)					
TOTAL	194.81 (0.5337)	194.74 (0.5335)					
2007 Clean Air Plan Over-Projected F	2007 Clean Air Plan Over-Projected Emission Reductions						
DIFFERENCE	-68.13 -(0.1867)	-93.3 -(0.2556)					

^a Converted to tons per day:

 $^{(194.91 \}text{ tons/year})*(1 \text{ year/365 days}) = 0.5340 \text{ tons/day of ROC emission reduction}.$

Table 3. BREAKDOWN OF THE 2007 BASE YEAR SOLVENT EMISSIONS DATA BY INVENTORY CATEGORIES^a

Descriptions	ROC Emissions, tons per year (tons per day)	Percent of the Total
1. ARB Area-Wide Category for Degreasing (EIC 220-204-XXXX-0000 and 220-208-XXXX-0000)	678.90 (1.86000)	52.85%
2. ARB Area-Wide Category for Cleanup Solvent Emissions Associated with Auto Refinishing, Metal Parts and Products Coatings, Wood Furniture and Fabricated Products Coatings Category (EIC 230-240-8300-0000)	54.60 (0.21000)	4.25%
3. ARB Area-Wide Category for Cleanup Solvent Emissions Associated with Printing (EIC 240-995-80000-0000)	21.54 (0.05901)	1.68%
4. ARB Area-Wide Category for Cleanup Solvent Emissions Associated with the use of Adhesives and Sealants (EIC 250-292-8202-0000 and 250-292-8250-0000)	5.52 (0.02124)	0.43%
5. ARB Area-Wide 'Other' Solvent Category for (EIC 299-995-8000-0000)	28.54 (0.10978)	2.22%
6. ARB Area-Wide Category for Cleanup Solvent Emissions Associated with Fiberglassing (EIC 410-403-5018-0000)	0.32 (0.00124)	0.03%
7. ARB Area-Wide Category for Solvent Cleaning Emissions from the use of Consumer Products (EIC 510-506-XXXX-0000)	412.45 (1.13000)	32.11%
8. ARB Area-Wide Category for Cleanup Solvent Emissions Associated with Architectural Coating Use (EIC 520-520-XXXX-0000)	26.00 (0.10000)	2.02%
9. Santa Barbara County APCD Point Source Inventory for Emissions from Solvent Cleaning Machines and Solvent Cleaning, Cleanup Solvent Emissions Associated with Auto Refinishing, Metal Parts and Products Coatings, Wood Furniture and Fabricated Products Coatings, Printing, Adhesives and Sealants, Fiberglassing, and Application of Architectural Coatings (EICs 220-204-XXXX-0000, 220-208-XXXX-0000, 230-240-8300-0000, 240-995-80000-0000, 250-292-8202-0000, 250-292-8250-0000, 410-403-5018-0000, and 520-520-XXXX-0000)	56.63 (0.15516)	4.41%
TOTAL	1,284.51 (3.64642)	100.00%

^a The District included this table in response to requests from the regulated community. The table shows the ROC emission contributions by the different inventory categories.

Table 4. PERCENTAGE BREAKDOWNS OF THE 2007 BASE YEAR SOLVENT EMISSIONS DATA BY INDUSTRY TYPES^a

	Point Sources						
Breakdown Description	Mining (includes Oil & Gas)	Electronic Device Mfg	Medical Device Mfg	Aircraft and Aerospace	Other ^b	Area Sources	
Percentage Compared to the Total Stationary Source Emissions (56.63 TPY, 0.1552 TPD)	28.02%	15.81%	27.43%	21.48%	7.25%	-	
Percentage Compared to the Total Emissions (1284.51 TPY, 3.6464 TPD)	1.24%	0.70%	1.21%	0.95%	0.32%	95.59%	

Table 5. COST-EFFECTIVENESS FOR REPLACING TWO HIGH-ROC COLD CLEANERS WITH ONE AQUEOUS UNIT $^{\rm c}$

Control Option: Switching from Two High-ROC Cold Cleaners to:	Cost per Year	Cost- Effectiveness (\$/ton of ROC reduced)
One Low-Use Batch- Loaded Automated Aqueous Unit	-\$112 (savings)	-\$2,560 (savings)
One Average-Use Batch-Loaded Automated Aqueous Unit	-\$362 (savings)	-\$3,320 (savings)
One High-Use Batch- Loaded Automated Aqueous Unit	-\$412 (savings)	-\$1,880 (savings)

^a The District included this table in response to requests from the regulated community. The table shows the emissions contributions (percentages) by different industry types based on the District point source data and the ARB area source inventory. In cases where more than one category was applicable (e.g., emissions from the manufacturing of electronic equipment used in aerospace vehicles), staff included the data in the end use category. The largest category of emissions, the ARB area-wide degreasing category, may also include data from the point source industry types shown in this table.

^b Includes facilities that are not in the other categories (e.g., a wooden dashboard manufacturer, concrete batch plants, an architectural product manufacturer, automobile refinishing, furniture coating/staining operations, various metal parts and products coating operations, a water treatment system manufacturer, and a sign manufacturer).
^c Reference: San Joaquin Valley Unified Air Pollution Control District, Final Staff Report - Amendments to Rule 4662 (Organic Solvent Degreasing Operations), May 11, 2001.

$\label{thm:cost-effectiveness} \mbox{For Replacing} \\ \mbox{A High-roc cold Cleaner with an Aqueous or enzyme unit} \\ \mbox{a} \\ \mbox{b} \\ \mbox{cold cold cleaner with an Aqueous or enzyme unit} \\ \mbox{a} \\ \mbox{cold cold cleaner with an Aqueous or enzyme unit} \\ \mbox{cold cold cleaner with an Aqueous or enzyme unit} \\ \mbox{cleaner with an Aqueous or enzyme$

Control Option: Switching from One High-ROC Cold Cleaners to:	Cost per Year	Cost- Effectiveness (\$/ton of ROC reduced)	
Low-Use Aqueous Unit	\$545	\$12,940	
Average-Use Aqueous Unit	\$903	\$8,560	
High-Use Aqueous Unit	\$1,393	\$6,600	
Low-Use Enzyme Unit	\$370	\$8,120	
Average-Use Enzyme Unit	\$430	\$3,800	
High-Use Enzyme Unit	\$470	\$2,080	
One Low-Use Batch- Loaded Automated Aqueous Unit	\$130	\$9,440	
One Average-Use Batch-Loaded Automated Aqueous Unit	\$240	\$2,320	
One High-Use Batch- Loaded Automated Aqueous Unit	\$790	\$3,840	

Click <u>here</u> to return to the list of Appendices in the Background Paper.

^a Reference: San Joaquin Valley Unified Air Pollution Control District, Final Staff Report - Amendments to Rule 4662 (Organic Solvent Degreasing Operations), May 11, 2001.



Appendix H Santa Barbara County Identification of Existing Federal and APCD Regulations that Apply to the Same Equipment or Source Type Covered in Rule 321

This section is included to comply with the California Health & Safety Code Section 40727.2 requirements.

Federal Air Pollution Control Requirements

The federal requirements in the below-referenced statutes apply to the same equipment or source types covered by Rule 321:

- 40 CFR, Part 63, Subpart T, National Emission Standards for Hazardous Air Pollutants: National Emission Standards for Halogenated Solvent Cleaning. (Solvent cleaning machines.)
- 40 CFR, Part 63, Subpart GG, National Emission Standards for Aerospace Manufacturing and Rework Facilities. (Handwipe cleaning in the aerospace industry.)

Santa Barbara County Air Pollution Control District Requirements

These are shown in the following table.

Table 1. RULES THAT APPLY TO SOLVENT CLEANING MACHINES AND SOLVENT CLEANING SUBJECT TO RULE 321

GENERIC REQUIREMENTS	AFFECTED EMISSION UNITS	BASIS FOR APPLICABILITY
RULE 201: Permits Required	All emission units	Emission of pollutants
RULE 202 : Exemptions to Rule 201	Applicable emission units	Insignificant activities/emissions,
		per size/rating/function
RULE 210: Fees	All emission units	Administrative
RULE 212 : Emission Statements	All emission units	Administrative
RULE 302 : Visible Emissions	All emission units	Particulate matter emissions
RULE 303: Nuisance	All emission units	Emissions that can injure,
		damage or offend.
RULE 317: Organic Solvents	All emission units	Emission of pollutants
RULE 322 : Metal Surface Coating	All emission units	Composition of organics in all
Thinner and Reducer		metal surface coating thinners
		and reducers shall not be
		photochemically reactive
RULE 324: Disposal and	All emission units	Solvent disposal requirements
Evaporation of Solvents		
REGULATION VIII: New Source	All emission units	Addition of new equipment or
Review		modification to existing
		equipment. Applications to
		generate ERC Certificates.
REGULATION XIII (RULES 1301-	All emission units	A stationary source is a major
1305): Part 70 Operating Permits		source.

A review of Table 1 indicates that there are no overlapping or conflicting averaging provisions, units, or any other pertinent provisions associated with emission limits.

Click here to return to the list of Appendices in the Background Paper.



Appendix I Santa Barbara County Clarification of Rule Issues

The District worked closely with the regulated community to develop special approaches to their individual needs and to clarify rule text. As a result of these efforts, staff received extensive feedback and input during the development stages. Also, members of the regulated community raised questions about the intent of certain rule provisions through discussions with staff and at the rule development public workshops and meetings.

The following text provides clarification of rule issues and consolidates comments/responses.^a To help the reader locate a specific issue, a table of contents is provided below.

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^a Comments received during the formal public comment period preceding the Board adoption hearing on the proposed rule changes, and staffs response to these comments, will be presented to the District Board of Directors as part of the rule adoption process.

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Rule 102

Request to Modify the Definition of Reactive Organic Compound

<u>Question/Issue</u>: The definition of "reactive organic compound" should be updated to include the following exempt compounds:

Methyl formate, tertiary-butyl acetate, HFE-7100, and HFE-7200

<u>Answer/Response</u>: The District is revising the *reactive organic compound* (ROC) definition by incorporating all of the 40 CFR, Part 51, Section 51.100(s) exempt compounds. The PAR 102 ROC definition includes a note on there being a Rule 202.D.10.1 gatekeeper on some of the *exempt compounds*. This note indicates:

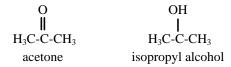
Rule 202.D.l0.l requires an Authority to Construct and Permit to Operate when using more than one gallon per year per stationary source of any one the following exempt compounds: methyl formate, tertiary-butyl acetate, HCFC-225ca, HCFC-225cb, HFC-43-10mee, HFC-245fa, HFC-365mfc, or HFE-7100 [(CF₃)₂CFCF₂OCH₃ or $C_4F_9OC_2H_5$].

The new Rule 202.10.1 provision will override and negate any otherwise applicable permit exemptions if a source uses more than one gallon per year per stationary source of any of the eight above-listed compounds. The need to issue Permits on the use of these compounds stems from ARB not providing a recommendation to include these as exempt compounds. This approach will allow the District the opportunity to perform any CEQA and/or health risk assessments associated that may be triggered by such use.

Adding IPA to the Exempt Compound List in the Rule 102 Definition of "Reactive Organic Compounds"

<u>Question/Issue</u>: IPA should be considered to be an exempt compound (i.e., a non-ROC). IPA is very similar in chemical nature, structure and ozone forming capabilities to acetone which has already been de-listed.

Scientific justification for exemption of IPA can be found in the chemical structure of IPA in comparison to the structure of acetone which is currently exempted in Santa Barbara County and the entire United States. Acetone and IPA are differentiated by the mere substitutions of an atom of oxygen for a hydroxyl group.



<u>Answer/Response</u>: When the Environmental Protection Agency lists IPA as an exempt compound in the 40 CFR, Part 51, Section 51.100(s), definition of volatile organic compounds (VOC), the District will consider modifying the Rule 102 definition of reactive organic compounds to include this compound.

Definition of 'Coating'

<u>Question/Issue</u>: On the new definition of "coating" in Rule 102, is it the APCD's intent to include adhesives and sealants?

Answer/Response: Yes. (The "coating" definition is from SJV Rule 4663.)

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Definition of 'Solvent' Including Toxic Air Contaminants (TACs)

Question/Issue: Why is the District including TACs in the project?

<u>Answer/Response</u>: The District wants Rule 321 to apply to non-ROC solvent such as methylene chloride and other TAC solvents not covered by a MACT (NESHAP). Staff has seen that the adoption of some new and revised rules for reducing ROC emissions could have the tendency to increase TAC emissions. For example, coating manufacturers complying with ROC limits may replaced an ROC solvent in a coating with a material that is classified as both a non-ROC and TAC. By including TACs in the solvent definition, there should not be a significant increase in TAC emissions from the revised Rule 321.

Question/Issue: This rule is being promulgated in response to an ROC control measure, not as a toxic air contaminant control measure. If the District wants to regulate TAC solvents, CARB or the APCD should first develop an air toxic control measure. The regulated community is requesting that TAC be taken out of the *solvent* definition.

Answer/Response: Including TACs in the project will (1) allow TAC solvents to be controlled by Rule 321, which is consistent with the District's mission to protect public health, (2) provide a method to deter TAC increases, (3) give sources incentives to reduce TAC emissions by using airless/air-tight SCMs or alternative solvents, and (4) be consistent with CEQA documents on the control measure.

Question/Issue: In the draft Background Paper, Appendix K, under the industry impacts from rule 102, it indicates that there are no impacts from the new definitions. If there are no impacts from including TACs in the project, why have it? The District needs to either change Appendix K to say yes there are some impacts (e.g., a health risk assessment may be triggered) or take TACs out.

<u>Answer/Response</u>: The addition of the TAC text to the solvent definition is not changing our permitting review process. Thus, there will be no effect on when TAC screening and/or health risk assessments will be done. The District has updated the Background Paper's Appendix K to reflect some of the other potential impacts due to changing the solvent definition and the Rule 202 changes.

<u>Question/Issue</u>: Some of the members of the regulated community do not believe the District has the authority to control TAC solvents as proposed in this rulemaking effort.

Answer/Response: Air districts have a long-standing authority to regulate toxic air contaminants.

<u>Question/Issue</u>: Have other air districts regulated toxic air contaminants through their solvent cleaning machine and/or solvent cleaning rules?

<u>Answer/Response</u>: Other air districts have not been as explicit on regulating TACs as the District's proposed approach.

In SC Rule 1122, Solvent Degreasing, the applicability section indicates that the rule applies to SCMs that carry out solvent degreasing operations with a VOC solvent or a NESHAPs halogenated solvent.

SC Rule 1171, Solvent Cleaning Operations, Section (a) indicates that the purpose of the rule is to reduce volatile organic compounds, toxic air contaminants, and ozone-depleting or global warming compounds from the use, storage and disposal of solvent cleaning materials in solvent cleaning operations and activities.

The state prohibited the use of several TACs in recent modifications to the state Consumer Product regulation on multi-purpose solvent and paint thinner products.

Definition of 'Solvent' and the Rule 321.B.1 Exemption

<u>Question/Issue</u>: Earlier drafts of PAR 102 and PAR 321 were confusing on the definition of "solvent" and the Rule 321.B.1 exemption provision. Is it the District's intention that Rule 321 will apply to a solvent that contains only a trace amount of TAC?

<u>Answer/Response</u>: No, if a solvent contains a TAC in excess of 2 percent by weight, then the Rule 321 will apply. The revised PAR 321.B.1 text now reads:

- 1. Any solvent cleaning machine equipped with and any solvent cleaning performed with a solvent (including emulsions) that contains two percent by weight or less of each of the following:
 - a. Reactive organic compounds (as determined by Environmental Protection Agency method 24), and
 - b. Toxic air contaminants (as determined by generic solvent data, solvent manufacturer's composition data or by a gas chromatography test and a mass spectrometry test).

Any person claiming this exemption shall maintain the records specified in Sections R.1.a.1) and R.1.a.2) in a manner consistent with Section R.3 and make them available for review.

'Solvent Cleaning' Definition

<u>Question/Issue</u>: The "solvent cleaning" definition should include "loosely held" text to avoid confusion and to differentiate processes where loosely held contaminants like grease and oils are readily removed from surfaces versus processes requiring scrapping and/or stripping.

<u>Answer/Response</u>: The new "solvent cleaning" definition proposed in amended Rule 102 is modeled on the SJV Rule 4663 definition. Although the proposed definition does not use the term "loosely held," it does include the adjective "uncured" in several places. Also, the District is adding a "stripping" definition in Rule 102 and text in the definitions of "solvent cleaning" and "solvent cleaning machine" to clarify when "stripping" does and does not apply.

Clarification of the "Stripping" Definition

Question/Issue: Would the removal of dried waxes (requires toluene) be considered "stripping"?

Answer/Response: No, the process of removing wax from a part or product with a solvent falls within the PAR 102 definition of "solvent cleaning." Toluene (ROC content 866 g/l) may be allowed per the PAR 321.M.1, Table 1, limits depending on the solvent cleaning category.

Request to Include the Definition of Toxic Air Contaminant'in Rule 102

<u>Question/Issue</u>: The District should include a definition of "toxic air contaminant" in Rule 102 to help sources understand the requirements.

<u>Answer/Response</u>: OK, the District added the following definition to PAR 102:

"Toxic Air Contaminant" means "Toxic air contaminant" as defined in Health and Safety Code Section 39655.

To help sources understand what compounds are TACs per Health and Safety Code Section 39655, staff developed a list of TACs. This list is provided as Appendix M, to the Rule 321 project's Background Paper.

Scope of the "Application Equipment" Definition

<u>Question/Issue</u>: Does the District view metal deposition (e.g., evaporation, sputtering) as an "application operation"? I'd recommend adding some language in PAR 321 to make this clear.

<u>Answer/Response</u>: Yes, technically a "metal deposition operation" is considered to involve "application equipment." PAR 102 includes new definitions for "application equipment" and "coating." The scope of these definitions includes "metal deposition operations." PAR 321.B.22 provides exemptions for film deposition processes and related maintenance operations.

Rule 201

Rule 201 Permitting Program and Issuing Permits with Pounds per Day and Tons per Year Emission Limits

Question/Issue: Why does the District issue permits with pounds per day and tons per year limits?

When a permit is issued in pounds per day, lowering the ROC content of individual materials does not result in a net air quality improvement, unless the permit is also amended. Thus, sources with permits that have been issued in pounds per day should be exempt from all prohibitive rule VOC limit requirements.

<u>Answer/Response</u>: Provisions in Regulation VIII, New Source Review (NSR), have thresholds based on pounds per day and tons per year. These thresholds are the genesis for the APCD to issue permits with conditions limiting emissions in pounds per day and tons per year.

The revised Rule 321 will limit the solvent's ROC content, which may result in an air quality benefit depending on the existing specific operation and solvents involved.

If the revised Rule 321 provisions achieve emission reductions for activities that have already been offset, then the offset liability would be reduced. The permit holder could choose to revise the permit accordingly. Rule 802.E.2 and E.3 provisions require that there be a net air quality benefit.

Rule 201 Permitting Program and the Need for a PTO Modification when Switching Solvents

<u>Question/Issue</u>: Will a source permitted to use an ROC solvent need to get a modified Permit to Operate if it wants to switch to a different compound?

Answer/Response: No, unless there was going to be an increase in ROC emissions that exceed the currently permitted rate or an increase in TAC emissions that exceed a toxic risk assessment emissions cap. A source using a TAC should already be subject to health risk analysis (HRA) on a periodic basis per the AB 2588 process. During a new source review process, the District does a health risk screening analysis and performs more-detailed modeling if needed. If the PTO did not require a modification, when the District performs the permit reevaluation we will update any health risk data to reflect the use of the current solvent.

<u>Question/Issue</u>: What about switching from an ROC solvent to a TAC solvent, would there be TAC emission limits in the permit?

Answer/Response: No, only a toxic risk assessment gatekeeper in the permitting records.

Rule 202

Meaning of Liquid Surface Area'

<u>Question/Issue</u>: On the Rule 202.U.2.a exemption provision, we are concerned that there may be some interpretation on the surface area being the surface area of the drum under the drain and not the drain.

<u>Answer/Response</u>: The District added text to Rule 202.U.2.a and the definition of "Solvent/Air Interface Area" in Rule 321 to specify it is the area of the drain for remote reservoir solvent cleaning machines.

<u>Support Documentation Required When Claiming the Exemption for Remote Reservoir SCMs (Aggregate Surface</u> Area is Less than 10 Square Feet)

<u>Question/Issue</u>: Will the proposed amended rules require sources to provide support documentation on their use of remote reservoir solvent cleaning machines to ensure that the 10 square feet aggregate threshold is not exceeded?

<u>Answer/Response</u>: An existing Rule 202 provision already requires this and the District is not proposing any revisions to that requirement.

Sources claiming an exemption under Rule 202.U (including Section 2.a, which generally applies to remote reservoir solvent cold cleaning machines) are currently required to keep records per Rule 202.D.1. At a large source with numerous remote reservoir SCMs, the District recommends that the records be routinely updated (monthly or, at a minimum, quarterly) to ensure that the Rule 202.U.2.a "10 square feet" exemption applicability threshold limit is not exceeded.

Existing sources claiming the Rule 321.B.2.b "small surface area" exemption are required to maintain quarterly records per the existing Rule 321.P.2 provision. Thus, there should already be procedures in place for such sources for demonstrating they are eligible for the exemption claim.

New Term'Cleaning Agents'

Question/Issue: In earlier drafts of revised Rule 202.U.2.c and d, there is a new term: cleaning agents. Why not just say "solvent."

<u>Answer/Response</u>: OK, the District now proposes to replace the existing current "materials" text with "solvent" or "solvents."

55 Gallons of Solvent per Year Permit Exemption Limit

<u>Question/Issue</u>: Rules 202.U.3 needs to be revised to address the use of low-ROC solvents such that the 55 gallons per year threshold is not triggered when using low-ROC solvent.

<u>Answer/Response</u>: The District added text to this section to exclude low-ROC solvents from the tally when determining compliance with the 55 gallons per year per source threshold figure.

<u>Question/Issue</u>: Our interpretation of the Rule 202.U.3 exemption is that any facility at a stationary source that uses more than 55 gallons per year of wipe solvents is required to get an air permit for its overall solvent use.

<u>Answer/Response</u>: The 55 gallons per year or less usage rate provision is a "stationary source" limit, not a "facility" limit. The District modified Rule 202 on June 19, 2008 to clarify that the 55 gallons per year usage is a stationary source limitation.

Wipe Cleaning Permit Exemption

<u>Question/Issue</u>: Delete Rule 202.U.3 because other air districts do not require permits for solvent wipe cleaning.

<u>Answer/Response</u>: The District added the provision as a gatekeeper in 1997 when there were significant changes made to Regulations II and VIII. We added the gatekeeper text at the request of the Environmental Protection Agency. We would reconsider this request if the EPA suggested that we remove it.

Confusing Text in Existing Rule 202.U.3.

<u>Question/Issue</u>: Rule 202.U.3 indicates, "Equipment used in wipe cleaning operations ..." Wipe cleaning is typically done by hand without employing equipment. Is it the District's intent to exempt wipe cleaning from permit requirements?

<u>Answer/Response</u>: No, it is the District's intent to require permits for wipe cleaning operations that exceed 55 gallons per year per stationary source. The District has revised the text for clarification.

Rule 321

Rule 321's Complexity

<u>Question/Issue</u>: Some members of the regulated community believe the rule is too complicated and hard to follow.

<u>Answer/Response</u>: The District is working with the regulated community to improve rule clarity on the modified text. The SCM and solvent cleaning requirements are similar to the provisions found in other district rules. However, our "packaging" of the requirements is a little different. Some air districts have one rule for SCMs and another rule for solvent cleaning. For PAR 321, the SCM requirements are in Sections D - L and the solvent cleaning requirements are in Sections D and M.

To provide additional guidance on the provisions, staff prepared the Background Paper's Appendix L, Flowchart Overviews of Key Provisions of Rule 202 and Proposed Amended Rule 321.

Request to Not Modify Rule 321

<u>Question/Issue</u>: "Leave well enough alone." Presently, while Santa Barbara's air quality continues to improve it is particularly perplexing why this type of law that restricts basic manufacturing competitiveness would be proposed as essential to maintaining compliance with current state and federal ozone standards.

Answer/Response: For many years, manufacturers in other areas in the state (e.g., South Coast AQMD, San Joaquin Valley Unified APCD, Ventura County, Bay Area AQMD, Sacramento Metropolitan AQMD areas) have complied with requirements similar to the ones we proposed. Adopting the revised Rule 321 is necessary to comply with the state requirement to adopt every feasible control measure and is part of the Federal Ozone Maintenance Plan. The District has been very accommodating to industry requests for exemption and/or proposals for specific cleaning categories with high ROC solvent limits. We do not anticipate that the regulated community will be significantly impacted by the adoption of the proposed rule revisions. In some cases, industry may find cost savings by switching to new technologies and/or aqueous solvent cleaning methods.

Solvent Emissions from Hospitals (and Other Health Care Facilities) and Janitorial Services

<u>Question/Issue</u>: Why do the District rules exempt or not apply to 1) IPA solvent wipe cleaning emissions at hospitals and other health care facilities, and 2) solvent cleaning emissions from commercial janitorial services?

We request the rulemaking and enforcement authority assigned to the District, allowing regulation of stationary sources, be applied evenhandedly to all local businesses and with objective scientific rationale.

Answer/Response: The revised rule needs to meet the "every feasible measure" requirement in state law. In general, if other air districts have adopted rules and such rules have achieved emission reductions, then the Santa Barbara County APCD should also adopt similar control measures. No air districts have regulated emissions of IPA from wipe cleaning at hospitals or solvent cleaning emissions from janitorial services.

Analysis indicates that the IPA solvent cleaning emissions at hospitals and other health care facilities are less than 1 percent and the commercial janitorial cleaning emissions are about 4.5 percent of the total solvent emissions in the inventory.

The cleaning techniques used in hospitals and other health care facilities and by janitors do not lend themselves well to the solvent cleaning control techniques found in the industrial setting. The District has added exemptions into Rule 202 and 321 to clarify that such cleaning is not subject to permitting or the solvent cleaning provisions (reference PAR 202.U.4 & 5 and PAR 321.B.7 & 14.)

Ozone Depleting and/or Global Warming Compounds

Question/Issue: Will the revised rule regulate ozone depleting and global warming compounds?

Answer/Response: It is not the purpose of Rule 321 to regulate ozone depleting and global warming compounds. If such a compound is an ROC or TAC, Rule 321 will apply (unless the solvent is otherwise exempt from Rule 321). For an ozone depleting and global warming compound that is not an ROC or TAC, it will not be subject to Rule 321. For example, HFE-7100 (two isomers) is not an ROC or a TAC, but it is a global warming compound. The use of HFE-7100 in a vapor SCM will not be subject to Rule 321. However, the use of this compound in excess of one gallon per year per source will require a permit per PAR 202.D.10.l. If the state added HFE-7100 to the TAC list, the compound would become subject to Rule 321.

<u>Question/Issue</u>: The District is modifying Rule 321 to reduce ROC emissions. There is no mandate to reduce ozone depleting compounds (ODCs) in this project. Thus, the regulated community requests that the revised Rule 321 not have specific requirements to reduce emissions of ODCs.

Answer/Response: PAR 102 will include a new definition for solvent:

"Solvent" means any liquid containing any reactive organic compound or any toxic air contaminant, which is used as a diluent, thinner, dissolver, viscosity reducer, cleaning agent, drying agent, or other similar uses.

Rule 321 will regulate any ODCs that meet the definition of "solvent" unless otherwise exempted by the rule. However, there will not be any specific requirements applicable to only ODCs.

<u>Question/Issue</u>: The regulated community requests that the District not include global warming compounds (e.g., hydrofluorocarbons and perfluorocarbons) in the rulemaking effort.

<u>Answer/Response</u>: The Rule 321 project is not specifically targeting global warming compounds or implementing requirements specific to these compounds. Any solvent containing a greenhouse gas that is not a toxic air contaminant and not an ROC (i.e., is listed as an "exempt compound" in the Rule 102 definition of "reactive organic compound") will be exempt from Rule 321 by Section B.1.

Exemptions and Definitions

<u>Question/Issue</u>: Ensure the revised rule clearly exempts (and defines) specific operations (e.g., Semiconductor, Aerospace). High volatility solvent cleaning, with isopropyl alcohol, toluene, methyl alcohol, etc. is required to prevent rust formation or other microscopic contamination.

<u>Answer/Response</u>: PAR 321.B.22 provides an exemption for some semiconductor manufacturing processes that need to use high ROC solvents like n-methyl-2-pyrrolidone (NMP). Stripping of photoresist is considered exempt per PAR 321, Section B.4. The District needs to regulate most of the processes involved in semiconductor manufacturing in lieu of adopting a separate semiconductor rule.

Section C includes definitions for "semiconductor manufacturing," "aerospace vehicle," "aerospace vehicle component," "space vehicle," "and "space vehicle component."

The portions of Rule 321 that will apply to the cleaning of the aerospace vehicles, their components, and satellites will allow the use of the aforementioned solvents.

Request to Exempt Isopropyl Alcohol

Question/Issue: Isopropyl alcohol should be exempt from Rule 321 when used in solvent wipe cleaning.

<u>Answer/Response</u>: We disagree. No air district with a solvent cleaning rule has exempted IPA solvent cleaning from their rules. To do so would be inconsistent with the mandate to adopt every feasible measure. Further, IPA is a reactive organic compound that is also a toxic air contaminant. Thus, the proposed amended Rule 321 requirements will apply when IPA is used in solvent cleaning machines and solvent cleaning.

<u>Question/Issue</u>: Isopropyl alcohol is non-photochemically reactive solvent. Per Rule 317, sources may use up to 3000 pounds (or 430 gallons per day) of isopropyl alcohol before implementing add-on control equipment. The District should exempt IPA from all of the PAR 321 requirements.

<u>Answer/Response</u>: IPA is not a "photochemically reactive solvent," but it is a "reactive organic compound." It is also a toxic air contaminant. Unlike Rule 317, PAR 321 will apply to materials that are classified as an ROC, TAC, or both. Thus, the proposed amended Rule 321 requirements will apply when IPA is used in solvent cleaning machines or when performing solvent cleaning.

Request to Exempt Small Containers (e.g., One Liter) from Rule 321 Solvent Cleaning Requirements

Question/Issue: PAR 321 should exempt containers having a capacity of one liter or less in volume; including containers that are filled on site using industry approved pumps and aerosol products.

<u>Answer/Response</u>: The PAR 321 Sections B.9 and B.11.b provide partial rule exemptions for the use of aerosol products and small containers (e.g., spray bottles, squirt bottles, and other containers having a capacity of one liter or less). However, depending on the category, some solvent cleaning activities using such containers will need to use low-ROC materials.

Loss of Rule 321 Exemptions

Question/Issue: Why is the District deleting the current Rule 321.B.4.f exemption for small sealed degreasers?

<u>Answer/Response</u>: The APCD proposes to delete the 10 gallons capacity enclosed solvent cleaner exemption because the revised rule will govern airless and air-tight solvent cleaning machines. Making such enclosed solvent cleaners subject to Rule 321 is consistent with approaches used by other air districts and the mandate to implement every feasible measure.

<u>Question/Issue</u>: Why is the District removing the Rule 321 exemptions in Sections B.2.a and b for solvent cleaning machines with a capacity of one gallon or less or a surface area of less than one square foot?

<u>Answer/Response</u>: The current Rule 321.B.2.a and b exemptions need to be removed for 1) consistency with the revised applicability provision, 2) to make the new solvent cleaning requirements applicable, and 3) to make the revised SCM requirements applicable.

Use of a solvent with a container that has one gallon capacity or less is considered to be "solvent cleaning." This is clarified in the new Rule 102 definition of "solvent cleaning machine," which indicates: "... Buckets, pails, and beakers with capacities of 3.785 liters (1.00 gallon) or less are not considered solvent cleaning machines. However, the use of such a container or similar containers (e.g., hand-held spray bottles) with a solvent for cleaning is considered to be solvent cleaning ..." There are many new provisions in the PAR 321 that will apply to solvent cleaning that would otherwise be exempt from the rule if the 321.B.2.a exemption was not removed.

The removal of the "less than one square foot evaporative surface area" exemptions is needed because the revised Rule 321 provisions will apply to degreasers that were previously exempt. For example, the sink-on-adrum cleaners (remote reservoir SCMs) will need to meet the 50 g/l and other Rule 321 requirements, unless they are subject to an applicable exemption.

Request to Exempt Paint Clean Up Operations that Use Solvents

Question/Issue: The cleaning of paint clean up operations should be exempt.

<u>Answer/Response</u>: The District disagrees that the cleaning of application equipment should be exempt. Similar to requirements in other air districts, PAR 321.M.3 will require the use an enclosed system (or equivalent) when using a solvent with an ROC content of greater than 50 grams per liter to clean spray application equipment.

Compounds that are Classified as being both a "Toxic Air Contaminant" and a "Non-Reactive Organic Compound"

<u>Question/Issue</u>: What compounds are classified as being both a toxic air contaminant and a non-reactive organic compound? When these compounds are used in concentrations exceeding two percent, the PAR 321.B.1 exemption will not apply (i.e., the PAR 321.B.1.b gatekeeper would be exceeded).

Answer/Response: To date, the District has identified six compounds that fall into this category:

- 1. tert-butyl acetate (t-BAc), CAS Number: 540-88-5
- 2. methylene chloride (METH), dichloromethane (DCM), CAS Number: 75-09-2
- 3. perchloroethylene (PERC), tetrachloroethylene, CAS Number: 127-18-4
- 4. 1,1,2-trichloro-1,2,2-trifluoroethane (CFC-113), CAS Number: 76-13-1
- 5. 1,1,1-trichloroethane (TCA); methyl chloroform, CAS Number: 71-55-6
- 6. trichlorofluoromethane (CFC-11), CAS Number: 75-69-4

This list may change due to additional compounds being identified or additions to 1) the TAC list and/or 2) the Rule 102 ROC definition's "exempt compound" list.

Methods for Determining a Solvent's ROC Content

<u>Question/Issue</u>: Will the District require that a solvent user have an EPA method 24 test done to determine the ROC content of a solvent or will the VOC data from a material safety data sheet (MSDS) be sufficient?

<u>Answer/Response</u>: If the solvent manufacturer based the VOC data in their MSDS on an EPA method 24 test, the District will not require the users to have a test performed. (Some MSDSs specify that the VOC data is based on EPA method 24.)

Another approach to verifying ROC content involves PAR 321.P.7, which will permit the identification of solvent components by manufacturer's formulation data (or ASTM International methods). Staff could determine the ROC content by using the manufacturer's formulation data coupled with solvent density data published in an acceptable reference document. This approach should be viable when the solvent in question is comprised of only one compound that is known to be an ROC,

If the manufacturer's formulation data approach is not feasible or the basis for the MSDS VOC data is in doubt or the accuracy of the manufacturer's data is questionable, the District may require solvent users to obtain EPA method 24 results.

'Stripping' Exemption

Question/Issue: On PAR 321.B.4, can a source use this exemption to strip cured sealants?

Answer/Response: Yes, we changed the text to include "cured sealants."

Removing Cured or Partially Cured Silicone from Production Equipment (e.g., Wooden Stirring Spoons)

<u>Question/Issue</u>: Under the PAR 321 requirements, will sources be allowed to use xylene and IPA to break apart the bonds of silicone that are partially or completely cured?

Answer/Response: Yes, the PAR 321.M.1 Table 1 limits will allow the cleaning of partially cured silicone:

- 1. Associated with maintenance and/or repair cleaning associated with the manufacturing of silicone, electronic, and/or medical devices, or
- From tools, equipment, and machinery involved with the manufacturing of silicone, electronic, and/or medical devices.

Xylene and IPA both have ROC contents below 900 grams per liter (g/l). This limit is being proposed in Rule 321, Section M.1. The PAR 321.B.8.exemption provides a similar 900 g/l limit for SCMs when performing such cleaning described in items 1 and 2 above.

The removal of <u>completely cured</u> silicone is considered to be "stripping," which is exempt by PAR 321.B.4. Rule 102 provides definitions that may help clarify these terms and requirements too:

- "Coating" means a material applied onto or impregnated into a substrate for protective, decorative, or functional purposes. Such materials include, but are not limited to, paints, varnishes, sealers, and stains.
- "Cured Adhesive, Cured Coating, or Cured Ink" means an adhesive, coating, or ink that is dry to the touch.
- "Stripping" means the use of solvent to remove materials such as cured adhesives, cured inks, cured sealants, cured or dried paints, cured or dried paint residues, or temporary protective coatings.

Exemption for Stripping Cured Coatings, etc.

<u>Question/Issue</u>: The provisions of the proposed rule should not apply to stripping of cured coatings, cured adhesives, and cured inks.

<u>Answer/Response</u>: We concur; PAR 321, Section B.4 provides an exemption from stripping cured coatings, cured adhesives, and cured inks, except when removing cured materials from spray application equipment.

Exemptions for Cleaning Operations Subject to Other APCD Rules

<u>Question/Issue</u>: PAR 321 should provide exemptions for any cleaning operations that are subject to other APCD rules. The SJVUAPCD and VC rules provide such exemptions.

Answer/Response: PAR 321.B.6 provides such exemptions.

ROC Limits for Batch Solvent Cleaning Machines Cleaning Electro-Optical Devices

Question/Issue: The PAR 321 should allow the use of solvents, such as isopropyl alcohol and cyclohexane/isopropyl alcohol mixtures, that have ROC contents greater than 50 g/l in batch SCMs, as required by government contracts for 1) electro-optical devices used in the aircraft decoys and satellites, and 2) high precision optics designed to sense, detect, or transmit light energy.

<u>Answer/Response</u>: Batch solvent cleaning machines used to clean high-precision optics will be allowed to use such solvents per the PAR 321.B.8 exemption.

Exemption from Sections H.7, I.7, and K.6

Question/Issue: Does PAR 321.B.8 (paragraph after c) exempt all of Sections H, I, and K, or only the effective date?

<u>Answer/Response</u>: This paragraph only exempts qualifying SCMs from the solvent ROC content limit (50 g/l or less). The other provisions of Section H, I, and K need to be met. The requirement for the solvent to have a 50 g/l of ROC content or less is within each of the referenced sections: H.7, I.7, and K.6. Operators of SCMs not eligible for the PAR 321.B.8 exemption will need to comply with the solvent ROC limit of 50 g/l or less by the effective date, which will be one year from the date the Board adopts the rule.

Specific Exemptions from the ROC Limits for Highly Technical and/or Precision Equipment Cleaning

<u>Question/Issue</u>: The cleaning of solar cells, fluid systems, avionic equipment, laser optics, telescopes, and microscopes should be exempt from Rule 321 requirements.

<u>Answer/Response</u>: The District has provided exemptions from the Rule 321 ROC limits in PAR 321.B.8.a for these items. The revised text indicates:

Cleaning of solar cells, laser hardware, scientific instruments, high-precision optics, telescopes, microscopes, avionic equipment, and aerospace and military fluid systems.

<u>Question/Issue</u>: The PAR 321.B.8.a exemption includes scientific instrument, but the definition of "scientific instrument" does not include telescopes and microscopes.

Answer/Response: Staff added microscopes and telescopes into the Rule 321.B.8.a exemption list.

Analytical Equipment Exemption

<u>Question/Issue</u>: The use of solvents to 1) clean laboratory equipment, and 2) dilute ("cut") samples during a laboratory analysis should be exempt.

<u>Answer/Response</u>: PAR 321.B.8.b provides an exemption from the rules' ROC content limits for cleaning in laboratory tests and analyses. And Section B.19 provides an exemption when using a solvent as a diluent (cut).

Request to Exempt Research and Development Programs from Solvent ROC-Content Limits

<u>Question/Issue</u>: PAR 321 should include an exemption from the rule's solvent ROC-content limits for research and development (R & D) programs.

Answer/Response: The District added such a provision for short-term (less than 2 years) R & D programs in PAR 321.B.8.b.

Aerosol Solvent Exemption

<u>Question/Issue</u>: Rule 321 should include an exemption for the use of small quantities of aerosol solvents and the threshold should be on a facility basis.

<u>Answer/Response</u>: The proposed amended Rule 321, Section B.9, includes a partial exemption for aerosol products. The exemption's upper usage rate limit is 160 ounces per day per facility.

Exemptions/Requirements for Squeeze Bottles, Beakers, and Solvent Containers Having 1 Gallon Capacity or Less

<u>Question/Issue</u>: Use of squeeze bottles, beakers, and bench scale solvent containers are critical to our operations. What exemptions and/or requirements in the PAR 321 will apply to their use?

Answer/Response: The PAR 321 Sections B.9 and B.11.b provide partial rule exemptions for the use of small containers. However, such solvent cleaning activities using small containers will need to comply with the PAR 321.M.1, Table 1, ROC limits, which may require use of low-ROC materials depending on the cleaning category. Also, the PAR 321.D, M.2, R, and possibly S provisions apply. If the container has a capacity greater than 1 gallon, the operation qualifies as using a "solvent cleaning machine," per the PAR 102 definition for this term.

There Should be No ROC Limits When Cleaning Application Equipment Associated with Satellite Coatings and Radiation-Effect Coatings

Question/Issue: The PAR 321 ROC limits should not apply when cleaning application equipment used in:

- 1. satellite coating operations, and
- 2. radiation-effect coating operations.

Answer/Response: The PAR 321.B.10 includes such exemptions.

Exemption from the Solvent Cleaning ROC-Content Limits for Sources Using 55 Gallons of Solvent per Year or Less

<u>Question/Issue</u>: Will the revised Rule 321 provide an exemption from the solvent cleaning ROC content limits for sources using 55 gallons of solvent per year or less?

<u>Answer/Response</u>: Yes, such sources will not be subject to the PAR 321.M.1, Table 1 limits (per PAR 321.B.15). Solvents with a reactive organic compound content of 50 g/l of material or less will not count towards the 55 gallons per year aggregate limit. However, the "good housekeeping" requirements of Section D and the provisions in Sections M.2, 3, R.2, R.3, and possibly S will apply to sources exempt by Section B.15.

Solvent Cleaning Exemption for Offshore Oil and Gas Platforms

<u>Question/Issue</u>: Requiring wipe cleaning solvents to have a low ROC content for solvent cleaning on offshore oil and gas platforms will create wastewater quality discharge issues.

<u>Answer/Response</u>: The District added an exemption (Rule 321, Section B.16.g) to address this concern. This new exemption limits the solvent ROC content to 800 g/l and the solvent ROC composite partial pressure to no greater than 8 mm of Hg at 20 °C when performing wipe cleaning on offshore platforms. Mineral spirits are available that will comply with the ROC content and pressure limits.

Cleaning of Vacuum Chambers

<u>Question/Issue</u>: What are the requirements when wiping down vacuum chambers with n-methyl-2-pyrrolidone (NMP) solvent?

<u>Answer/Response</u>: The cleaning of vacuum chambers should qualify for the PAR 321.B.22 exemption, which provides an exemption for some manufacturing and maintenance processes that need to use NMP solvent.

Suggested Changes to the Definition of 'Electronic Components'

Question/Issue: Ensure that the revised rule definition of "electronic components" is broad (e.g., includes semiconductor, charged coupled devices, thermal electric coolers, etc.). Also, include clarification in the rule's support document of what is meant by the definition's text "except for the actual cabinet in which the components are housed."

<u>Answer/Response</u>: Staff has worked closely with the regulated community to expand the definition of "electronic components" to ensure that it is sufficiently broad.

The definitions of "Electrical Apparatus Components" and "Electronic Components" both include the phrase, "except for the actual cabinet in which the components are housed." The intent is to allow manufacturers of electrical apparatus and/or electronic components to use solvents with high ROC contents (up to 900 g/l), but require the use of low-ROC solvents when cleaning the final cabinet in which the completed components are installed. However, for equipment requiring a high degree of cleanliness (e.g., components and devices manufactured and/or assembled in clean rooms), Rule 321.B.8 allows the use of high-ROC content solvents.

Gas Turbine Engine Cleaning

Question/Issue: What provisions of Rule 321 apply to the cleaning of internal parts of a gas turbine engine?

<u>Answer/Response</u>: Equipment used in the cleaning of gas turbine engines is considered to be a "Gas-Path Solvent Cleaner," as defined in PAR 321, Section C. Rule 321 provisions will not apply if the solvent is exempt by Rule 321.B.1. It is the District's understanding that these operations use solvents that have an ROC content less than 2 percent, by weight.

If the operation is not exempt from Rule 321, then the following Rule 321 sections apply:

- 1. D, General Operating Requirements,
- 2. F, Additional Operating Requirements for Gas-Path Solvent Cleaners, and
- 3. G, General Equipment Requirements for Solvent Cleaning Machines.

Definition of 'Medical Device'

<u>Question/Issue</u>: Should the definition of "medical device" include the raw materials used to manufacture medical devices like the definition of "aerospace vehicle component" has?

Answer/Response: Yes, we believe it should. Thus, the District revised the definition to include such text.

Request for a Definition of and Provisions for "Solvent Cleaning Stations"

Question/Issue: The PAR 321 should include a definition of "solvent cleaning stations" and provisions for them similar to those found in the South Coast AQMD Rule 1164, Semiconductor Manufacturing. This definition indicates: "SOLVENT CLEANING STATIONS is a workplace equipped to remove surface contaminants using a liquid or vapor solvent containing volatile organic compounds."

<u>Answer/Response</u>: The District disagrees. Adding such a definition could cause confusion over when a *solvent cleaning machine* is employed and when *solvent cleaning* is being performed. The new definitions in PAR 102 and the PAR 321 provide clear delineations for these two terms and the requirements that apply to them.

Change in the Method for Determining the Contact Location of the Solvent/Air Interface for Vapor SCMs

Question/Issue: The current *air-vapor interface* (*solvent/air interface* in PAR 321) definition indicates that the effective top of the vapor layer may be determined as the maximum height where condensation occurs on a cold metal object lowered into the vapor zone. Under PAR 321, the location of contact is defined as the mid-line height of the primary condenser coils. What is the basis for this change?

Answer/Response: The District is modeling the Rule 321 project SCM terms and definitions on those found in 40 CFR, Part 63, Subpart T, National Emission Standards for Halogenated Solvent Cleaning. Staff prefers the mid-line height basis for determining the location of contact of the solvent/air interface because it is easier to determine and it is consistent with the federal provisions. It should be noted that this change may affect the freeboard ratio figure. For additional information see "Requirement for Vapor SCMs to Have a Freeboard Ratio of 1.0," page 1-23.

Level of Stringency of the PAR 321 Requirements

Question/Issue: The District proposes to modify Rule 321 using solvent rules in the South Coast AQMD and San Joaquin Valley Unified APCD as models. However, these areas have extreme non-attainment status, while Santa Barbara County has federal maintenance attainment status. In light of this situation, the District should use rules adopted before 1999 as the models for the current PAR 321.

<u>Answer/Response</u>: The APCD modeled the proposed revised requirements for solvent cleaning machines on South Coast (SC) Rule 1122, as adopted on July 11, 1997. The proposed solvent cleaning requirements are modeled on a combination of rules: South Coast Rule 1171, as adopted on October 8, 1999, and SJV Rule 4663, as adopted on December 20, 2001. Staff also considered and added exemption provisions from the Ventura County APCD solvent rules.

Santa Barbara County is nonattainment for the state ozone standard and the proposed amended Rule 321 requirements are consistent with the state requirement to adopt every feasible measure.

Inspection and Maintenance Plan Not Required for Solvent Cleaning Machines

<u>Question/Issue</u>: Will the proposed amended rules require sources to have inspection and maintenance (I & M) plans to monitor operations of remote reservoir solvent cleaning machines?

Answer/Response: No, PAR 321 does not include any provisions for I & M plans.

Enforcement of the New ROC-Limits

<u>Question/Issue</u>: How will the District enforce the requirement to use low-ROC solvents, especially at unpermitted facilities like auto repair shops?

<u>Answer/Response</u>: We have a county-wide surveillance program, where we are visiting all facilities, permitted and unpermitted, that may have emissions. Through this surveillance program we determine compliance with permit requirements and with Rule 321 provisions. Regarding the use of low-ROC solvents, a vendor (Safety-Kleen) indicated to us that they will ensure that the equipment they service complies with the revised Rule 321 requirements.

Requirements for Remote Reservoir Cleaners that Were Previously Exempt from Rule 321

<u>Question/Issue</u>: What requirements will apply to the sink-on-a-drum units under the PAR 321? These have typically been exempt by the Rule 321.B.2.b one square foot exemption, which is being deleted.

<u>Answer/Response</u>: If a sink-on-a-drum (remote reservoir) SCM is not exempt by a provision in Rule 321.B, such unit will be subject to:

- 1. Section D, General Operating Requirements,
- 2. Section G, General Equipment Requirements for Solvent Cleaning Machines,
- 3. Section H, Additional Equipment Requirements for Remote Reservoir Cold Cleaning Machines (includes the requirement to use a solvent with an ROC content of 50 g/l or less),
- 4. Section I, Additional Equipment Requirements for Batch Cold Cleaning Machines. a
- 5. Section R, Recordkeeping Requirements,
- 6. Section S, Reporting Requirements, b and
- 7. Section T, Compliance Schedule.

Question/Issue: What Rule 321 requirements may be a challenge or difficult for these units to meet?

<u>Answer/Response</u>: The PAR 321.H.5 provision may be triggered, which would require dimensions such that the freeboard ratio is 0.75 or greater. This could occur if the solvent employed is a high volatility solvent (Safety Kleen 105 is a high volatility solvent unless its temperature is never at 98 °F or higher).

A source may eliminate the need to meet the 0.75 freeboard ratio requirement by switching to a low volatility solvent. Such a solvent may be an aqueous- or detergent-type cleaning agent or a solvent with an ROC content of 50 g/l or less. For SCMs that were previously exempt, PAR 321.T.2.b.3 provides a deadline of 365 days from the rule amendment date for sources to comply with the Section H provisions.

^a Section I applies if the solvent container is accessible for dipping or soaking parts.

^b Annual reporting applies if the remote reservoir SCM is subject to a Permit to Operate.

CEQA Analysis for the Rule 321 Project's "Closed Container" Requirement

<u>Question/Issue</u>: The California Environmental Quality Act (CEQA) analysis for the Rule 321 project needs to assess the increased generation of hazardous waste as a result of the proposed closed container requirement.

This analysis should include the secondary emissions generated by the transportation of this hazardous waste material to approved waste collection sites. For example, existing APCD rules do not prohibit the air drying of rags during miscellaneous wipe solvent operations. The proposed rule would eliminate this practice, resulting in the generation of a new hazardous waste stream.

<u>Answer/Response</u>: The APCD does not foresee that there will be any unmitigated significant CEQA issues. The proposed equipment designs, limits, and operating requirements in PAR 321 have been established in many other California air districts.

Meaning of "Tight-Fitting Cover"

Question/Issue: In PAR 321.D.1, what does "tight-fitting cover" mean?

Answer/Response: A top that is made specifically for a container would typically be a tight-fitting cover. Something with a bunch of visible gaps would not be a tight-fitting cover. A tight-fitting cover is one that will stay on if bumped and is not easily knocked off. A cover that is too big for the top of the container and could easily be pushed off would not be a "tight fitting cover." It doesn't have to be vapor-tight.

Cover Requirements

<u>Question/Issue</u>: The existing requirement should be expanded to allow the removal of the cover for additional reasons (e.g., to perform monitoring, inspections, or repairs).

<u>Answer/Response</u>: The District revised the text to indicate that the covers shall not be removed or opened except to process work or perform monitoring, inspections, maintenance, or repairs that require the removal of the covers.

Necessity of the Proposed New Housekeeping Requirements

<u>Question/Issue</u>: The District indicated that it modeled the new PAR 321.D.10 to 12 requirements on provisions in:

- 1. 40 CFR Part 63, Subpart T for NESHAP Halogenated Solvent Cleaning, and
- 2. South Coast AQMD Rule 1122.

This rule should not address TACs; thus no Rule 321 requirements should be based on the federal regulation. In addition, the SCAQMD is a highly industrial air basin containing many more of these solvent sources, and that air basin is classified as extreme nonattainment of federal ozone air quality standards, whereas Santa Barbara County is in attainment of federal ozone attainment standards. Therefore, these new requirements need not be imposed upon sources within the jurisdiction of the SBCAPCD.

<u>Answer/Response</u>: The same "good housekeeping" techniques found within the federal regulation for reducing hazardous air pollutant emissions will also reduce ROC emissions. Also, using the provisions within SC solvent rules as models for the SBC solvent rule is consistent with the state requirement to adopt every feasible control techniques.

Enforcement of the Proposed New Housekeeping Requirements

Question/Issue: The new proposed housekeeping requirements in PAR 321.D could lead to increased costs for operators, increased recordkeeping and reporting requirements, and a greater potential for Notices of Violation during facility inspections. There is also a concern that these housekeeping requirements will be unequally enforced, because the SBCAPCD will not have the resources to inspect the unpermitted sources, beyond periodic inspections. Thus, we request the elimination of PAR 321, Sections 10 to 13.

<u>Answer/Response</u>: The District needs to include these requirements because they have been implemented in other air districts and they are necessary to meet the state requirement for the adoption of "every feasible measure." To provide equal enforcement, the APCD conducts surveillance of unpermitted SCMs.

Looking at the PAR 321.D.10 - 13 housekeeping provisions individually:

321.D.10 - Requirement to Clean Up Solvent Spills This expands the existing Rule 321.D.1 provision, which indicates, "Solvent, including waste solvent, shall not be stored or disposed of in a manner that will cause or allow evaporation into the atmosphere." It is similar to text in SC Rules 1122(c)(1)(L) and 1122(c)(2)(P) and 40CFR §63.462(c)(5). We believe that it a reasonable requirement that operators clean up solvent spills immediately when they occur.

321.D.11 - Solvent Levels are Not to Exceed the Fill Line This is an extension of the existing Rule 321.D.2 provision, "The solvent cleaner . . . shall be installed, operated, and maintained in proper working order." The District is proposing the same text found in SC Rule 1122(c)(1)(M) and 1122(c)(2)(Q). Preventing overfilling of SCMs will help to reduce spills and improve compliance with other requirements (e.g., maintaining the proper freeboard height/ratio, helping to avoid solvent splashing outside of the SCM).

321.D.12 - SCM Solvent Transfer Methods At the request of industry, the District modified the earlier text (which had been modeled on the 40 CFR §63.463(d)(8) provision). The currently proposed text is verbatim from SC Rule 1122(c)(1)(E). We believe it is reasonable to require this technique, which will help in reducing emissions from solvent transfers.

321.D.13 - Positioning Ventilation Fans This provision is virtually the same one found in current Rule 321.G.10, SC Rule 1122(c)(1)(K), SC Rule 1122(c)(2)(N), and VC Rule 74.6.1.C.10. We cannot eliminate this provision as it is currently in the Rule 321, which EPA has incorporated into the State Implementation Plan.

Allowing Minimal Amounts of Solvent Atomization Without Emission Controls

<u>Question/Issue</u>: The rule should provide limited exemptions to 1) the solvent atomization prohibition, and 2) the requirement to employ add-on control equipment when atomizing solvent.

<u>Answer/Response</u>: PAR 321.B.11 provisions provide exemptions from the solvent atomization prohibition for specific equipment and containers.

Transferring Solvent

Question/Issue: The PAR 321.D.12 (dated May 14, 2009) indicates that the solvent shall be transferred using threaded or other leakproof couplings. So, if you have a transfer pump, you can't put the pump in the bottom of the drum, because you don't have a threaded or leakproof coupling?

<u>Answer/Response</u>: The District revised this provision using text from the SC Rule 1122; the PAR 321.D.12 provision now indicates:

Draining or filling solvent containers shall be performed at a level lower than the liquid solvent surface.

Question/Issue: How would solvent draining per D.12 be applied to a small cleaning machine that has a small container? In my case, we pick up a tub containing about 2 - 3 gallons of solvent and pour it directly into the bulk storage drum. Filling another container to transport the solvent doesn't seem like it would result in any emission decrease.

Answer/Response: Staff added an exemption in PAR 321.B.23 to cover such a scenario:

The provisions in Section D.12 shall not apply to a solvent container (e.g., a bucket, pail, or tub) having a maximum capacity of 8 gallons or less, provided the operator drains the solvent from such container by pouring it directly into a storage container.

Request to Eliminate Potentially Antiquated Parts of Rule 321

Question/Issue: There are unnecessary sections of PAR 321 that can be deleted.

Answer/Response: Although the Santa Barbara County APCD point source inventory may not include certain devices (e.g., gas-path cleaners, in-line SCMs, or cross-rod SCMs), they could be currently in use without being in the inventory due to their permit-exempt status. As shown in the Background Paper, Appendix L, Figure 1, Page L-3, there are several permit exemptions that apply to such equipment. It is necessary to retain these SCM requirements for new units as well. For these reasons, the District is reluctant to remove requirements from the existing rule (which EPA has approved into the State Implementation Plan).

PAR 321.H.7, I.7, & K.6 Sentence Structure

<u>Question/Issue</u>: The language after the *effective date* references in PAR 321 H.7, I.7, and K.6 appears incomplete.

<u>Answer/Response</u>: We reviewed the text in question and found that the sentence structure is correct. The intent is to require SCMs to be equipped with solvents having an ROC content of 50 g/l or less, effective one year from the date of the rule revision, unless a SCM is controlled by an emission control system meeting the requirements in Section N.

Using Section H.7 as an example, the proposed (abbreviated) text is: "Any person who... operates... any remote reservoir cold cleaning machine shall ensure that it is equipped with the following: ... 7. ... solvent that contains 50 grams of reactive organic compound per liter of material or less."

The omitted text provides qualifiers on 1) when the 50 g/l requirement becomes effective and 2) how the use of add-on control equipment may be used in lieu of meeting the 50 g/l requirement.

Aqueous Solvents Will Not Work for Many Solvent Applications

Question/Issue: For many solvent-cleaning operations, aqueous cleaners are functionally ineffective.

<u>Answer/Response</u>: The proposed amended Rule 321 solvent ROC limits take into account the specific needs for the various industries. For electronic and medical device manufacturing and silicone manufacturing processes that require a higher degree of cleanliness, the rule will allow up to 900 grams of ROC per liter. Similar limits for the different types of facilities and processes have been successfully used in other air districts.

Cleaning Electronic Components and Medical Devices with the IPA

Question/Issue: IPA should be allowed to be used when cleaning electronic components and medical devices.

<u>Answer/Response</u>: Such cleaning operations may be eligible for an exemption in Section B.8. If not, the Section M.1, Table 1, ROC limit is 900 g/l for these categories. IPA has an ROC content of 785 g/l in its purest form. Thus, undiluted IPA may be used under the proposed provisions for the aforementioned categories.

Making Certain Solvents Illegal

<u>Question/Issue</u>: This proposed rule would make certain hydrocarbon solvents illegal for use in wipe cleaning operations.

Answer/Response: That is true for solvent cleaning categories 1) not eligible to be exempt by a Section B provision (e.g., B.15 – the 55 gallons per year exemption), or 2) that need to use solvents with a higher ROC content than the ones allowed in Section M.1, Table 1. The District is proposing to adopt solvent cleaning provisions that have been successfully implemented in other air districts. Further, where there is a need to use high ROC solvents, we have included higher limits or an exemption in the rule.

Rule 321 Impacts

<u>Question/Issue</u>: Revised Rule 321 will impact businesses that are already operating under permit with the District. Effectively, the "reward" that businesses will receive for their years, and in many cases decades, of compliant operation and fee remittance is an outright ban on select materials (e.g., IPA) that are essential to performing the ordinary course business activities of their enterprises. The District can achieve the reduction in ozone precursors required by their Clean Air Plan by the adoption of other proposed rules.

<u>Answer/Response</u>: Some industries (e.g., automotive repair shops) that have not already switched over will see a positive impact to their operating costs from complying with the revised Rule 321 requirements. The change to aqueous- or detergent-type solvents has resulted in cost-savings in others regions where the control techniques have been implemented.

The APCD is not proposing to ban IPA (for more detail, see the response to the "Disclosure of Emission Inventory Data and Banning IPA" topic, under "321 - Support Data," page <u>I-26</u>). The District's approach to regulating solvent cleaning is reasonable, consistent with the APCD Clean Air Plan, and fulfills the requirement to adopt "every feasible measure."

The District disagrees that the emission reductions from revising Rule 321 can be achieved through the adoption of other proposed control measures. The adoption of PAR 321 will achieve more than one-half a ton per day of ROC emission reductions. Those emission reductions exceed the combined emission reductions from all of the other proposed revised control measures listed in the 2007 CAP, Table 4-3.

Setting the General Solvent ROC-Content Limit at 50 or 25 Grams per Liter

Question/Issue: The project should be based on a "general solvent use" ROC-content limit of 50 g/l, not 25 g/l.

<u>Answer/Response</u>: When we first proposed the solvent rule changes in the 2001 Clean Air Plan, air district's with solvent cleaning requirements were setting the solvent limit for general use at 50 grams per liter. Although these air districts have since lowered the rules' ROC limits to 25 g/l for general solvent use, we will continue to propose the 50 g/l limit for this category as committed to in the 2001 CAP. And, we will be using earlier versions of the other air district rule requirements for establishing the ROC limits.

ARB and EPA have recommended that the District revise the rules to have the 25 g/l cut-off. Therefore, a possibility exists that ARB and/or EPA will not approve the revised rule at the proposed ROC limits.

PAR 321 and Interactions with Rules 322 and 324

<u>Question/Issue</u>: The District should examine the interaction between Rule 322, Metal Surface Coating Thinner and Reducer, and Rule 324, Disposal and Evaporation of Solvents, with the proposed revisions to Rule 321. Could Rules 322 and 324 be eliminated, as they appear to be redundant following the adoption of the proposed rule changes?

Answer/Response: No, the provisions in Rules 322 and 324 should not be repealed. There is no interaction or interdependency between the PAR 321 and the Rule 322 or Rule 324 requirements. Rules 322 and 324 are general umbrella- or catch-all-type rules that do not have any requirements specific to the use of solvent cleaning machines or provisions on solvent cleaning. Also, the PAR 321 will have limited applicability. Thus, a person disposing of a solvent not subject to the Rule 321 solvent disposal provisions would be subject to Rule 324 requirements

PAR 321 and Interaction with Rule 317

Question/Issue: How will the requirements of Rule 317, Organic Solvents, interact with those in PAR 321?

<u>Answer/Response</u>: Rule 317 is a general umbrella- or catch-all-type rule that applies to a wide range of sources and regulates "photochemically" and "nonphotochemically" reactive solvents. Rule 321 regulates "reactive organic compounds," which includes a larger set of chemicals when compared to chemicals categorized as "photochemically reactive organic compounds."

Sources subject to Rule 321 are required to comply with all other applicable SBCAPCD prohibitory rules (including Rule 317). The modified Rule 321 will have limits on the ROC content of solvents, but not daily limits on ROC emissions.

Solvent Cleaning Emissions that Have Been Offset and the Need to Comply with Prohibitory Rule Requirements

<u>Question/Issue</u>: A source performing solvent cleaning that has offset the emissions at a 1.2 to 1 ratio should not be required to comply with the revised Rule 321 requirements because the emissions have been fully mitigated.

<u>Answer/Response</u>: Such permitted solvent activities need to comply with the permit conditions and all applicable rules. If the revised Rule 321 requires use of solvents with lower-ROC contents for the solvent cleaning operation having emission offsets, then the ROC-content requirements need to be met. In such a case, the offset liability would be reduced and the permit holder could choose to revise the permit accordingly.

Requirement for Vapor SCMs to Have a Freeboard Ratio of 1.0

Question/Issue: Under the PAR 321 requirements, will I need to increase the freeboard ratio in my vapor SCM to 1.0?

<u>Answer/Response</u>: Yes, if the SCM is subject to the PAR 321.J.8 or L.9 requirement and the SCM is not controlled by an emission control system complying with the Section N requirements. The deadline for complying with the increased freeboard ratio requirement will be one year from the date of rule adoption.

It should be noted that the method for determining the *solvent/air interface* has been revised to be the mid-line height of the primary condenser coils. This change may affect the freeboard ratio figure. For additional information see "Change in the Method for Determining the Contact Location of the Solvent/Air Interface for Vapor SCMs," page <u>I-17</u>.

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Use of a Low Volatility or Partial Pressure Alternative

<u>Question/Issue</u>: It is recommended that solvent cleaning with low volatility solvents be addressed in the rule. As currently proposed the rule may encourage the use of higher volatility solvents with lower ROC content, resulting in higher overall emissions. (E.g., replacing toluene with propylene glycol monomethyl ether acetate [PGMEA]).

<u>Answer/Response</u>: Other air districts have moved away from having composite partial pressure provisions in their rules. We believe that they found those provisions unnecessary and that industry did not substitute higher volatility solvents to comply with the rule because their solvent rules provided adequate specific exemptions.

Cleaning of "Clean Rooms" and General Work Areas

Question/Issue: What will the ROC-limit be for the cleaning of "clean rooms" and general work areas?

Answer/Response: Maintenance cleaning of "clean rooms" and general work areas associated with the manufacturing and/or repair activities involving electronics, medical devices, silicone manufacturing, or aerospace vehicles/payloads (and their components) will be limited to 900 g/l [PAR 321.M.1, Table 1, Cleaning Activities in (b)(ii) - (b)(iv) and (d)(iii)(II)]. The solvent ROC limit for "general" maintenance cleaning will be 50 g/l [PAR 321.M.1, Table 1, Cleaning Activity (b)(i)]. The PAR 321 includes a definition for "maintenance cleaning."

ROC Limits for Aerospace Solvent Cleaning

<u>Question/Issue</u>: What is the ROC solvent limit for solvent cleaning associated with aerospace applications in the proposed amended rule? All components of an assembly require the same high level of cleanliness to ensure all contaminants are removed. Under vacuum, any contamination, no matter how microscopic, may become loose or outgas causing system failure.

<u>Answer/Response</u>: 900 g/l per PAR 321.M.1, Table 1, Cleaning Activity (d), unless cleaning the coatings application equipment, in which case it is 950 g/l per the table's Cleaning Activity (c) limit.

Solvent ROC Content Limit When Cleaning Spray Application Equipment

<u>Question/Issue</u>: What is the solvent ROC content limit when cleaning spray application equipment under the proposed amended rule?

<u>Answer/Response</u>: For cleaning architectural coating application equipment, the Rule 321.B.2 upper exemption limit, is 950 g/l. The Section M.1, Table 1, also limits the ROC content to 950 g/l.

ROC Limits When Performing Repair and Maintenance Cleaning of Electronic and Cleaning Coatings Application Equipment

Question/Issue: What are the PAR 321 solvent ROC-content limits for:

- 1. electronic apparatus components & electronic components subject to repair or maintenance cleaning, and
- 2. the cleaning of coatings application equipment?

<u>Answer/Response</u>: The limits in PAR 321, Section M.1, Table 1, for the repair cleaning and maintenance cleaning of electrical apparatus components and electronic components is 900 g/l. The limit for cleaning coatings application equipment is 950 g/l.

PAR 321.M.1 Table 1 Limits

<u>Question/Issue</u>: It is recommended that solvent cleaning with low volatility solvents outside of a machine be addressed in the amended rules.

Answer/Response: The early South Coast AQMD and San Joaquin Valley APCD solvent cleaning rules included an option to comply with composite partial pressure limits or ROC limits. However, their current rules have ROC limits with no option to comply with a composite partial pressure limit. It appears that those air districts amended their rules to provide only ROCs limit and have worked around the cases where use of high-ROC solvents is needed by providing specific exemptions. In a similar manner, we are also providing many specific exemptions.

Adding a Specific Category to PAR 321.M.1, Table 1, for 'Silicone Manufacturing'

Question/Issue: Silicone manufacturing processes require the use of IPA. The raw silicone materials are used in many products including medical devices and electrical wire insulation, which require a high-degree of cleanliness. The District should provide ROC limits for silicone manufacturing that are equivalent to the limits for medical device manufacturing and electrical apparatus components & electronic components manufacturing.

<u>Answer/Response</u>: Agreed, the District added this category to the rule's Table 1, Cleaning Activities (a)(iv) and (b)(iv), with a 900 g/l limit. And we added a definition of *silicone manufacturing* in PAR 321.C.

Purging Operations

<u>Question/Issue</u>: PAR 321 should include allowances for purging operations using inert gases (e.g., nitrogen), air, and hydraulic fluid.

<u>Answer/Response</u>: The District has included *solvent flow* and *flush method* provisions in PAR 321.M.2.c for such operations. However, it should be noted that "degassing" operations subject to or specifically exempt from Rule 343 will be exempt from Rule 321 per proposed Section B.6.f.

Purging operations involving inert gases or air that are used to purge a solvent with an ROC and a TAC concentration at two percent or less would be exempt per Rule 321.B.1. However, purging with air/inert gases to remove solvents not eligible for the Rule 321.B.1 exemption or purging with hydraulic fluid will need to comply with the PAR 321.M.2.c provisions. (Hydraulic fluid has an ROC content > 2 percent.)

Meaning of 'Enclosed'

Question/Issue: Is there a definition of the word "enclosed"?

Answer/Response: No, however the Rule 321.M.3 text describes what an enclosed system will encompass.

Scope of the PAR 321.M.3 provisions and Omitting the Word 'Spray' from the Rule 321 Definition of 'Application Equipment'

<u>Question/Issue</u>: Does PAR 321.M.3 apply to solvent cleaning of all application equipment or just spray application equipment? Should the Rule 102 definition of "application equipment" be changed to "spray application equipment" to clarify that only spray application equipment is subject to the rules?

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<u>Answer/Response</u>: The intent of the PAR 321.M.3 provision as originally written was to require the cleaning of spray application equipment with either low ROC-content solvent or with the use of an enclosed system. To clarify, the District added the word "spray" in the appropriate places.

On the suggestion to add "spray" to the PAR 102 "application equipment" term, we prefer not to make this addition. The definition of "application equipment" applies throughout the rulebook and needs to be more general so that it can apply to items such as printing presses, trowels, paint brushes, rollers, etc. (PAR 321.B.2 also uses the term "application equipment" in several exemptions and Table 1.)

Methods for Determining Compliance with the PAR 321.N.6 Provision

Question/Issue: How will compliance with the PAR 321.N.6 provision be determined?

<u>Answer/Response</u>: In general, the District will determine compliance with this provision as part of the evaluation for the emission control system's Authority to Construct. During this evaluation, staff will calculate what the emissions would be 1) from the emission control system when a source uses specified quantities of non-complying solvents, and 2) if the source used the same quantities of complying solvents. If the calculated emission rate with a control system is less than the rate using uncontrolled complying solvents, then the project would comply with the PAR 321.N.6 requirement.

After the equipment is constructed, source tests of the emission control system's overall efficiency may be used in combination with usage records and calculations to verify compliance with the Section N.6 provision. Later compliance determinations (e.g., those associated with routine inspections and/or permit reevaluations) will include calculations for determining the theoretical emissions if complying solvents were used and the actual emissions from the control system. The actual controlled emission may be determined from usage records, solvent ROC contents, and new and/or historical source test results on the overall emission control system's efficiency.

Increased Recordkeeping Provisions

Question/Issue: PAR 321.R.1.b.3 requires sources performing solvent cleaning to record the amount of solvent used for each type of cleaning activity specified in Table 1. Businesses will need to modify recordkeeping to classify each cleaning activity, which will increase efforts related to recordkeeping with little benefit or reducing actual emissions to the atmosphere.

Answer/Response: Additional recordkeeping requirements are needed to provide a method for demonstrating and verifying that the higher-ROC solvents are used appropriately. The proposed revised recordkeeping provisions are similar to those found in other air district solvent cleaning rules. Industry has indicated that a need exists to allow the use of higher ROC-content solvents for various types of cleaning activities. We believe that the regulated community finds the additional recordkeeping costs an acceptable tradeoff so that they have available higher ROC limits for specific solvent cleaning activities.

Use of Blended/Mixed Solvents

Question/Issue: The rule needs to provide a method for solvent users to specify the "as-applied" solvent ROC content especially when they perform on site blending of solvents or prepare aqueous solvent from concentrate. Requiring businesses to buy solvents premixed, rather than separate, would only add to costs rather than reduce solvent emissions to the atmosphere.

<u>Answer/Response</u>: Section R.1.b.5 allows solvent users to determine solvent "as-applied" ROC content at the time of application. Sources may wish to obtain the District's approval of the mix ratio recordkeeping practices and ROC calculation method to ensure compliance with the Rule 321.R.1.b.5 provisions. Nothing in PAR 321 prohibits the mixing of solvents, provided the applicable ROC-content limits and other rule requirements (e.g., Section R.1.b.5) are met.

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Disclosure of Emission Inventory Data and Banning IPA

Question/Issue: The District should provide data on emission sources impacting our local air regardless of business class. In order for the District's Community Advisory Council, the APCD Board and the general public to make an informed decision regarding a ban on IPA use in our County, they should rightly be provided full disclosure of the stationary sources currently allowed to operate without permits.

<u>Answer/Response</u>: The APCD has provided the public with data on emissions that impact the local air quality in our Clean Air Plans. The 2007 CAP, Section 3, provides emission inventory data. Table 3-1 breakdown the ROC emissions for different categories (e.g. laundering, degreasing, etc). In addition, the District has included tables in the Rule 321 Background Paper, Appendix G, page <u>G-5</u> that provide percentage breakdowns on solvent emissions from different emission categories and industry types.

Staff prefers not to characterize any of the PAR 321 requirements as "banning" any particular compound. While certain parts of PAR 321 will limit a solvent's ROC content, there are many exceptions being built into the rule. Proposed amended Rule 321.H.7, I.7, and K.6 include solvent ROC content limits for certain solvent cleaning machines (assuming they are not exempt by a provision in PAR 321.B). Also, PAR 321.M.1 includes solvent ROC limits for certain operations, many of which are higher than the ROC content for undiluted IPA. By providing flexibility to specific industry operations while adopting proven solvent emission reduction techniques, the District will meet the state requirement to adopt "every feasible measure."

Request for a Summary that Compares the Emissions Contribution for all Sources of Solvent Emissions

<u>Question/Issue</u>: The regulated community would like a comparison to others solvent users that need to control emissions. There should be a breakdown in percentages of medical device manufacturing, pharmaceutical, electronic device manufacturing, aerospace, and then the CAC, when we look at it, can see how much we are contributing to the emissions versus these two classes (hospitals and janitorial) that are being exempted.

<u>Answer/Response</u>: These summaries are provided in the Background Paper, Appendix G, page <u>G-5</u>, Tables 3 and 4.

Emission Reduction Calculations

Question/Issue: Some of us would like to see the calculations that support Table 1 in Appendix G.

<u>Answer/Response</u>: A document that details the emission calculation method is available from the District upon request.

Emission Reduction Estimates

Question/Issue: The numbers in the Background Paper are different (higher) from the ones shown in the Clean Air Plan.

<u>Answer/Response</u>: The emission reductions are actually lower. The APCD overestimated the emission reductions in the 2007 CAP. The Background Paper (Appendix G, Table 2, page <u>G-4</u>) provides a table to show the comparison of the emission reductions from the 2007 CAP analysis and the current rulemaking activity.

Emission Reductions from Hospitals, Janitorial, and Autobody Shops

<u>Question/Issue</u>: How much of the emission reductions are associated with hospitals and janitorial and autobody shops?

<u>Answer/Response</u>: There are no emission reductions anticipated for hospitals and janitorial solvent use due to their exempt status. For autobody shops, which are not included in the PAR 321 project, the 2008 rulemaking action indicated that the revised Rule 339 solvent requirements would achieve emission reductions of:

0.0096 TPD (2.50 TPY) in 2015, and 0.0102 TPD (2.65 TPY) in 2020

Unspecified ARB Area Source Categories

<u>Question/Issue</u>: The regulated community would also like to get more information (descriptions) on what goes into the "unspecified" categories.

<u>Answer/Response</u>: A document that provides information on this subject is available from the District upon request.

Emission Reductions from Auto Repair Shops

Question/Issue: What emission reductions are anticipated from the auto repair shops?

<u>Answer/Response</u>: Assuming 75 percent of the CES 83659 (EIC 220-204-0500-0000) emissions are associated with remote reservoir cleaners at auto repair shops, the PAR 321 ROC emission reductions will be:

0.2707 TPD (98.80 TPY) in 2015, and 0.2980 TPD (108.76 TPY) in 2020

Basis for Calculating Emissions from Hospitals and Janitorial Services

<u>Question/Issue</u>: I don't like the methodology that calculates emissions based on head-count; looking at the number of employees as a potential to emit. I just have a hard time seeing how that correlates. Purchase records would probably be the most accurate.

<u>Answer/Response</u>: The District is willing to consider alternative calculations that use a reasonable basis for determining these emissions.

Modeling Rule 321 on Other Air District Rules

Question/Issue: When drafting PAR 321, we do not need to follow the other air district's rules word for word, right?

<u>Answer/Response</u>: That is correct; we can be flexible, to a degree. We may run the risk of getting unfavorable recommendations and/or disapprovals from ARB and/or EPA if we stray too far from the provisions found in other air district solvent rules.

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Rule 323

Architectural Coating Application Equipment Cleaning

<u>Question/Issue</u>: Rule 323 does not contain any type of exemption for solvents used for cleaning coating equipment. Will the revised Rule 323 or 321 exempt solvents used for equipment cleaning?

<u>Answer/Response</u>: The District included an exemption in Rule 321.B.2 for the cleaning of architectural coating application equipment. Per the 2007 CAP, the District will revise either R321 or 323 to include solvent cleaning requirements later.

Rule 339

Requirement to Use Low-ROC Solvents for Auto Painting.

<u>Question/Issue</u>: How will the District's rule address the auto painting industry's need to use pre-sanding solvents that have high ROC contents?

<u>Answer/Response</u>: The District modified Rule 339 in 2008 to include a limited exemption in Rule 339.B.8 for pre-sanding solvents.

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Appendix J Santa Barbara County Comparison of the Adjoining Air District Permitting and Prohibitory Rules for Solvent Cleaning Machines and Solvent Cleaning

The Air Pollution Control Districts that border the Santa Barbara County APCD (SBC) include the San Joaquin Valley Unified APCD (SJV), the San Luis Obispo County APCD (SLO), and the Ventura County APCD (VC). For performing the comparisons of the proposed revised rules, staff considered the following categories:

- 1. Definitions found in the "definitions" rule of the rulebook,
- 2. Permit exemptions,
- 3. Prohibitory rule requirements for solvent cleaning machines, and
- 4. Prohibitory rule requirements for solvent cleaning.

The following provides a summary of the similarities and differences for each of these categories.

DEFINITIONS FOUND IN THE "DEFINITIONS" RULE OF THE RULEBOOK (SBC RULE 102)

In general, the SJV, SLO, and VC rules relative to solvent cleaning machines and solvent cleaning include definitions that are similar to the ones we are proposing for Rule 102. Generally, the definitions being added to Rule 102 are needed to clarify terms that are used in Rule 202 (Exemptions to Rule 201) and Rule 321 (Solvent Cleaning Machines and Solvent Cleaning). Some of the new Rule 321 terms may also be added to operation-specific rules (323, 330, 337, 349, 351, 353, or 354) when the SBC modifies them to include enhanced solvent cleaning requirements.

The SBC proposed amended Rule (PAR) 102 *solvent* definition includes *any liquid containing any reactive organic compound or any toxic air contaminant*. The SLO rules do not include a definition of *solvent*. And the VC and SJV solvent definitions are limited to reactive organic compounds (or volatile organic compounds, which generally means the same as reactive organic compounds). Thus, the VC and SJV *solvent* definitions do not include a toxic air contaminant (TAC) aspect.

The effect of including TACs in the PAR 102 *solvent* definition is that some solvents that would otherwise be exempt (because they have no ROCs), will be subject to Rule 321 (i.e., they contain TACs in concentrations greater than 2 percent, by weight).

PERMIT EXEMPTIONS (SBC RULE 202)

These are in several categories.

- Exceptions to Permit Exemptions. Currently, SBC has two exceptions to the permit exemptions. Rule 202, Section B.1 indicates any equipment, activity, or operations proposed by an applicant to be subject to an Emission Reduction Credit is not exempt. And Section B.2 indicates emission units that function for distributed electrical generation that are not certified under the ARB regulations are not exempt.
 - SJV and SLO have several exceptions to their permit exemptions. Their exceptions range from negating the exemption for an emission unit subject to New Source Performance Standards to negating an exemption where the owner of an otherwise exempt emission unit specifically requests a permit to operate. VC does not have any exceptions to its exemption rule.
- **Temporary Equipment Exemption.** SBC Rule 202.D.5 exempts temporary equipment provided certain conditions are met (e.g., emissions are 1 ton per year or less). The only temporary equipment exemption found in the SJV rules is for the temporary storage of gasoline in flexible containers used for certain purposes (Rule 2020.I.5). SLO and VC do not have an exemption provision for temporary equipment.

- Exemption for Stationary Sources that have Uncontrolled Actual Emissions less than 1 Ton per Year. This is an existing permit exemption in SBC Rule 202, Section D.7. SJV, SLO, and VC do not have a stationary source exemption provision.
- Exemptions for Low Emitting Units if Uncontrolled Emissions Never Exceed Two Pounds Per Day. The SJV Rule 2020.6.19 exempts low emitting units provided the equipment meets certain requirements. In general, the emissions need to be 1) less than or equal to 2 pounds per day or 2) less than or equal to 75 pounds per year. Also, the equipment cannot have emissions of hazardous air pollutants that pose a significant health risk.

SLO Rule 201.A.1 provides an equipment exemption for uncontrolled emissions that never exceed two pounds per day if certain requirements are met. The exemption does not apply if the equipment is subject to a New Source Performance Standard or a National Emission Standard for Hazardous Air Pollutants (NESHAP), emits a TAC, is located at a source that requires a Federal Title V (Part 70) permit, or the APCO has made a determination that the equipment may not operate in compliance with the SLO rules.

The VC and SBC rules do not have a similar exemption for low emitting equipment.

• Exemptions for Unheated Nonconveyorized Cleaning Equipment. Exemptions in the SJV Rule 2020.6.9 and the SLO Rule 201.J.2 are essentially the same. They provide an exemption for solvent cleaning using unheated nonconveyorized cleaning equipment. Both of these exemptions require that certain provisions be met (limited open surface area, limited solvent volume, only solvents with an initial boiling point above a given threshold are used, no more than 25 gallons per year of solvent may be lost to the atmosphere from all such equipment at a stationary source, and records are maintained to substantiate the exempt status).

The exemption in the VC Rule 23.F.10.c is somewhat similar (it has an allowable aggregated surface area and an allowable minimum initial boiling point for the solvent). However, the exemption differs from the SJV and SLO exemption in that it applies to *cold cleaners* and the equipment cannot emit 1,000 pounds of ROC or greater from all such cleaners at a stationary source during any rolling period of 12 consecutive calendar months.

The SBC exemption in proposed amended Rule 202.U.1 will apply to nonconveyorized solvent rinsing containers of 1 gallon capacity or less. The Section 202.U.2 exemption for solvent cleaning machines will continue to have exemptions similar to those in the adjoining air districts (e.g., exemptions for small surface area, aqueous cleaning solutions, and high boiling point solvent).

• Exemptions for Solvent Wipe Cleaning Operations. SBC Rule 202.U.3 provides an exemption for wipe cleaning operations provided the usage rate does not exceed 55 gallons per year per stationary source, records are maintained, and the aggregate emissions from all equipment subject to Rule 202.U.3 do not exceed a 10 tons per calendar year gatekeeper.

The VC Rule 23.F.10.d includes an exemption for wipe cleaning as discussed further in the next item. The SLO and SJV rules do not include a specific exemption for wipe cleaning.

• Exemptions for Solvent Cleaning Machines and/or Solvent Cleaning. The VC Rule 23.F.10.c was previously discussed under the *exemptions for unheated nonconveyorized cleaning equipment* category. In addition to that exemption (Rule 23.F.10.c) for *cold cleaners*, the VC Rule 23.F.10.d provides exemptions for qualifying *cold cleaners*, *vapor degreasers*, *wipe cleaning*, *dip cleaning*, *and flush cleaning*. To qualify for the Rule 23.F.10.d exemption, each of the following air pollutant emission rates need to be less than 200 pounds at a stationary source during any rolling period of 12 consecutive calendar months: ROC, methylene chloride, 1,1,1 trichloroethane, and perchloroethylene. The exemption does not include solvents used for coating, graphic arts, adhesive/sealant, and polyester resin operations.

The SBC Rule 202.U.2 exemption for solvent cleaning machines only applies to unheated devices. The wipe cleaning exemption in SBC Rule 202.U.3 has a *not to exceed* 55 gallons per year per stationary source

aggregate limit and other provisions as mentioned in the *exemptions for solvent wipe cleaning operations* category above. The only solvent cleaning machine exemptions specified in the SJV and SLO rules are the one discussed in the *unheated nonconveyorized cleaning equipment* category above. As previously mentioned, the SLO and SJV rules do not include a specific exemption for wipe cleaning.

• Exemptions that Could Apply to Solvent Cleaning and Exemptions for Miscellaneous Solvent Use. VC Rule 23.F.6 provides an exemption that could apply to solvents: nonrefillable aerosol cans. The exemptions in VC Rules 23.F.7, 8, and 9 cover organic compound emissions from a variety of operations.

These include:

- 1. facility, grounds, and building maintenance and repair not including maintenance and repair of process and industrial equipment when performed by contractors;
- 2. janitorial maintenance (including graffiti removal); and
- 3. office and administrative use of solvents does not include production activities by facility involved in graphic arts.

The SLO, SJV, and existing SBC exemptions do not include these VC exemptions. The District is proposing to add exemptions for 1) janitorial cleaning (Rule 202.U.5) and 2) solvent cleaning to disinfect and decontaminate surfaces and equipment at hospitals, health care facilities, etc. (Rule 202.U.4). The adjoining air districts do not have an exemption similar to the proposed Rule 202.U.4 provision.

- Exemptions for Low-ROC Solvent Use. VC Rules 23.F.10.a and b exempt cleaning operations and materials if the cleaning agents:
 - 1. are certified by the SCAOMD as Clean Air Solvents, or
 - 2. contain no more than 25 g/l of ROC as used or applied, and no more than 5 percent by weight combined of methylene chloride, perchloroethylene, trichloroethylene, 1.1.1-trichloroethane, carbon tetrachloride, and chloroform.

SBC Rule 202.U.2.c exempts solvents with a ROC content of 2 percent or less by weight. An exact comparison of the percent by weight and the number of grams per liter is not possible without knowing the solvents density. SJV and SLO rules do not include a specific exemption for low-ROC solvents.

PROHIBITORY RULE REQUIREMENTS FOR SOLVENT CLEANING MACHINES AND SOLVENT CLEANING (SBC RULE 321)

The solvent cleaning machine and solvent cleaning requirements have several components, as outlined below.

• Applicability. The SLO Rule 416 does not have an *applicability* section. The SJV Rule 4662 indicates it applies to all organic solvent degreasing operations. The SJV Rule 4663 indicates it applies to any organic solvent cleaning performed outside a degreaser during the production, repair, maintenance, or servicing of parts, products, tools, machinery, equipment, or in general work areas at stationary sources; and to the storage and disposal of all solvents and waste solvent materials at stationary sources.

The VC Rule 74.6 *applicability* provision covers solvent cleaning and degreasing. It basically indicates that the rule applies to any person who performs solvent cleaning activities and any person who manufactures or supplies solvent for use in solvent cleaning activities in Ventura County (unless the cleaning activity is exempt from Rule 74.6 or the solvent used has an ROC content of 25 grams per liter or less). The VC Rule 74.6.1 indicates it applies to batch loaded vapor degreasers.

The SBC PAR 321 *applicability* provision indicates the rule will apply to *solvent cleaning machines* and *solvent cleaning*. The use of the *solvent cleaning machine* term is a new approach adopted only by the SBC. This term is essentially the same one found in 40 CFR, Part 63, Subpart T. Thus, there is an inherent difference in terms used to describe *degreasers* vs. *solvent cleaning machines* throughout PAR 321 when

compared with the adjoining APCD solvent rules. The SBC *solvent cleaning* term is modeled on the SJV Rule 4663 definition of *organic solvent cleaning*.

The SBC PAR 321 *applicability* provision is similar to the one found in the SJV Rule 4663. However, PAR 321, Section A, indicates, 'This rule shall apply to any person who owns, operates, or uses any solvent cleaning machine or performs any solvent cleaning ..." Thus, the owner, operator, and end user are responsible for compliance with Rule 321.

- **Exemptions.** These are in several categories:
 - **Wipe Cleaning.** SLO exempts wipe cleaning from the solvent rule requirements. There is no such exemption in the SJV, or the SBC PAR 321.
 - Low-ROC and Low-TAC Solvents. VC Rules 74.6 and 74.6.1 exempt solvents certified by the SCAQMD as Clean Air Solvents and solvent with an ROC-content no more than 25 grams per liter (as applied). The SJV Rule 4662 and 4663 have implied exemptions for solvents containing less than 25 grams per liter of ROC via the rules' definition of *solvent*. As mentioned in the previous discussion on SBC Rule 102, The VC and SJV *solvent* definitions only include solvents that contain ROCs. Thus, the VC and SJV solvent rules do not apply to non-ROC solvents that contain TACs.

SLO does not have an exemption in this category.

The PAR 321.B.1 *two percent or less* exemption is being expanded to apply to the solvent's ROC and TAC content. Thus, *solvent cleaning* and *solvent cleaning machines* will be exempt from Rule 321 (except for recordkeeping to substantiate the exemption claims) if the solvent has an ROC content <u>and</u> a TAC content of two percent or less. If either the ROC or the TAC content exceeds two percent, then the exemption will not apply.

• Small Capacity and/or Limited Surface Area. The SLO Rule 416 provides partial exemptions from emission reduction techniques for various units not exceeding certain thresholds.

The SJV Rule 4662, Sections 4.2 and 4.3 provide an exemption for qualifying degreasers that have an open top surface area of less than 1.0 square foot or with a capacity < 2 gallons.

The VC Rule 74.6, Surface Cleaning and Degreasing, does not include exemptions in this category. However, the VC Rule 74.6.1, Batch Loaded Vapor Degreasers, Section G.3 small vapor degreaser provisions provide exemptions from the requirements to install an automated parts handling system and enhanced emission control equipment. To qualify, the unit must meet certain size/capacity provisions and not emit more than 55 gallons per month.

The SBC is proposing to delete the general small cleaner exemptions (Rule 321.B.2) because the PAR 321 has new provisions that will apply to these smaller-sized containers and devices. The District is adding two limited exemptions (321.B.18 and 20) for vapor solvent cleaning machines. These provisions will exempt qualifying units from some of the new requirements for vapor solvent cleaning machines. There is also a partial exemption in PAR 321.B.23 to allow pouring solvent from small containers into bulk storage containers without the use of transfer hoses, piping, or tubes.

- Solvent Cleaning Machines Subject to 40 CFR, Part 63, Subpart T Provisions. The SLO Rule 416 and the SJV Rule 4662 do not have any exemptions in this category. Both the VC Rule 74.6 and 74.6.1 provide this exemption. Staff proposes that the SBC PAR 321 retain this exemption.
- Equipment and Operations Subject to Other Rules. The SLO Rule 416 does not have any exemptions in this category. The SJV Rule 4662 does not have any explicit exemptions in this category. However, SJV Rule 4662, Section 4.1, exempts cleaning outside a degreaser. This implies solvent cleaning subject to the SJV Rule 4663 is exempt from Rule 4662. The SJV Rule 4663, Section

4.3, provides exemptions to operations specifically subject to or exempted by 13 other rules.

VC Rule 74.6, Section E.1.f provides exemptions for any cleaning operation subject to one of the listed six prohibitory rules. Also, Section E.1.d of this rule includes an exemption for vapor degreasers. Batch loaded vapor degreaser are subject to Rule 74.6.1.

The SBC PAR 321, Section B.3 exempts dry cleaning operations (either subject to Rule 320 or the State Airborne Toxic Control Measure) from the entire Rule 321 provisions. Section B.6 provides exemptions from the *solvent cleaning* aspects of Rule 321 for eleven SBC prohibitory rules.

• Exemption from the ROC Limits for Solvent Cleaning When Using Limited Amounts of Solvent. The SLO solvent rule does not have an exemption in this category. The VC Rule 74.6, Section E.2.0, allows use of non-compliant solvent in certain circumstances. The facilitywide usage is to be less than 1 gallon per week, compliant solvents cannot be available, and records substantiating the exemption claim need to be maintained.

The SJV Rule 4663, Section 4.4, provides an exemption to the solvent cleaning ROC limits for stationary sources using no more than 55 gallons per any rolling, consecutive 365-day period. This SJV exemption requires that daily records be maintained to support the exemption claim. The SBC PAR 321, Section B.15 provides a similar exemption to the solvent cleaning ROC limits for stationary sources using no more than 55 gallons per year. PAR 321.R.2 requires that monthly and calendar year total records be maintained on a stationary source basis to support the exemption claim.

- Janitorial Cleaning (Including Graffiti Removal). This exemption is for solvent wipe cleaning associated with janitorial cleaning, but does not include the cleaning of general work areas at stationary sources. The SBC PAR 321, Section, B.7, the VC Rule 74.6, Section E.1.c, and the SJV Rule 4663, Section 4.1, include an exemption for janitorial cleaning. The SLO solvent rule does not have a similar exemption specific to janitorial cleaning, but their rule is for solvent cleaning machines. Further, the SLO rule has a general solvent wipe cleaning exemption.
- **Aerosol Solvent Cleaning.** The PAR 321.B.9 has a limited exemption (from the solvent atomization prohibition and the solvent ROC limit) for cleaning with aerosol solvents. The genesis of this exemption stems from provisions in the South Coast AQMD Rule 1171, Section (h)(4).

The VC Rule 74.6, Section E.1.b, provides an exemption for the use of aerosol products. The SLO and SJV solvent rules do not include an exemption for the use of aerosol solvent cleaning.

• Specific Parts Cleaning Requiring Higher-Degrees of Cleanliness. The SLO Rule 416 does not have any exemptions in this category.

The SJV Rule 4662 exempts the cleaning of electrical; high-precision optics; electronic applications; aerospace and military applications for cleaning of solar cells, laser hardware, fluids systems, and space vehicle components; and components used in research and development programs and laboratory tests for quality assurance. However, to qualify for the exemption, such cleaning must employ an unheated SCM that has an area of less than one square feet or a capacity of less than 2 gallons and a non-halogenated solvent. Further, the solvent usage needs to be less than five gallons per month and other provisions must be met.

The VC Rule 74.6, Section 2 provides exemptions from the solvent partial pressure and ROC content limits for equipment similar to the ones listed in the SJV Rule 4662. The VC Rule exemption list includes additional items as well (e.g., manufacturing cleaning of nuts and bolts intended for automotive racing applications and cleaning of precision-lapped mechanical seals in pumps).

The SBC PAR 321 includes exemptions on the solvent ROC content limit for several specific parts cleaning categories. The District modeled these exemptions on similar exemptions in the SJV and VC

rules.

- Gas-Path Cleaner. The SLO and SJV rules do not have any exemptions in this category. VC Rule 74.6, Section E.3 exempts aircraft engine gas path cleaning and gas turbine gas path cleaning from the requirements in 1) Section B.1 (solvent partial pressure and ROC content limits) and 2) Section B.2 (required cleaning devices and methods) if the solvent's ROC content is 200 grams per liter or less.
 - The SBC PAR 321 has special provisions applicable to gas-path cleaners and therefore does not have an exemption for these types of cleaners.
- Aircraft and Aerospace Vehicle De-Icing. None of the adjoining APCDs have this exemption. The SBC is adding the exemption because 1) the removal of moisture with a solvent (e.g., diluted ethylene glycol) is considered to be solvent cleaning, and 2) it is not our intent to regulate de-icing activities (no other air districts have applied their solvent cleaning rules to such).
- Exemption from Enhanced Control Techniques for Qualifying Small Vapor SCMs. For qualifying small units (solvent/air interface area less than 1 square foot or capacity less than 2 gallons), the SBC Rule 321 will allow equipment use without an automated parts handling system, a freeboard refrigeration device, or a superheated vapor zone. The genesis for this exemption stems from an exemption in the VC Rule 74.6.1. The SJV Rule 4662 provides a broader exemption, which has more qualifiers. The SLO solvent rule does not provide a similar exemption.
- Exempting Solvents When they Are Not Used for Cleaning. The VC Rule 74.6 includes an exemption for the use of solvent for purposes other than solvent cleaning activities. For example, a solvent may be used as coating thinner or to dilute a sample for laboratory analysis. It is not the intent of Rule 321 to regulate such uses. Thus, the SBC staff added an exemption similar to the VC Rule 74.6.E.1.h exemption. The SJV and SLO rules do not include such an exemption.
- Exemption from the Workload Area Limit and Enhanced Control Techniques for Qualifying Vapor SCMs Used in the Manufacturing of Electronic Components. This is a limited exemption for vapor cleaning machines used in the manufacturing of electronic components. This exemption (PAR 321.B.20) is unique to SBC and will allow qualifying vapor solvent cleaning machines to be operated without meeting the workload area limit (PAR 321.E.7) and without using the enhanced control techniques (J.8 and J.11.a, d, and e). The APCD is proposing this exemption based on input from Raytheon and their existing operations. Raytheon has indicated that they have a highly-specialized cleaning process for a product requiring a high degree of cleanliness. Further, they have been unable to find a suitable solvent replacement and/or equipment that would comply with the PAR 321 provisions while meeting their high-cleanliness standard.
- Solvent Wash Stations used in Medical Device Manufacturing Processes. The SBC proposes to exempt solvent sinks used during medical device manufacturing for product leak testing from certain rule requirements. The exemption (PAR 321.B.21) will allow such sinks to be used without meeting the requirements to have a minimum freeboard height/ratio and be employed without a low-ROC solvent. These sinks are currently exempt by the Rule 321, Section B.2–small surface area and/or capacity–exemption. Product solvent cleaning during the quality control/assurance testing is incidental to the process. Providing this exemption is consistent with the intent of PAR 321 to control emissions from solvent cleaning and solvent cleaning machines. The adjoining air districts do not include a similar exemption in their rules.
- Metal Lift-Off and Other Semiconductor and Microelectromechanical Operations. This exemption is unique to SBC; the adjoining air districts solvent rules do not include this category. The APCD is adding this exemption to clarify that metal lift-off operations and the other specifically listed operations are not subject to the Rule 321 requirements.

- **Definitions.** Generally, the definitions used in the SBC PAR 321 are different from those used by the adjoining air districts. As previously mentioned, the terms for *degreasers* are being modified to be consistent with the terms found in 40 CFR, Part 63, Subpart T. SBC is recommending that some of the definitions currently found within Rule 321 be relocated into the general definition rule (102).
- **Requirements.** There are several components to these provisions, as shown in the following summaries.
 - Operating Requirements. These are listed in SLO Rule 416, Section C, SJV Rule 4662, Sections 5.1.1, 5.2.2, 5.3.1, and 5.4.2, VC Rule 74.6, Section D, VC 74.6, Section C, and SBC PAR 321, Sections D, E, F, M, N, and O. The operating requirements are generally the same for all the air districts, with some minor variations. The SBC PAR 321 includes additional operating requirements not found in the other air district's rules, as listed below:
 - 1. Operating requirements for batch vapor and in-line vapor cleaning machines to have their idling mode covers and downtime mode covers in place when the equipment is in the respective mode.
 - 2. Operating requirements for gas-path solvent cleaners.
 - Equipment Requirements. These are listed in various sections of the SLO, SJV, SBC, and VC rules. The equipment requirements are generally the same for all the air districts, with some minor variations. The SBC PAR 321 includes additional equipment requirements not found in the other air districts rules. These additional equipment requirements are associated with the same equipment listed in the preceding "operating requirements" discussion.

The SBC PAR 321 will implement several enhanced control techniques, which become effective one year after the date of the revised rule adoption:

- 1. Vapor cleaning machines are to have dimensions such that their freeboard ratio is 1.0 or greater,
- 2. Cold cleaning machines, including remote reservoir cold cleaning machines, are to use solvents with an ROC-content of 50 g/l or less,
- Vapor cleaning machines employing a solvent with an ROC content of 50 g/l or greater need to have an automatic parts handling system, a superheated vapor zone, a freeboard refrigeration device, and other associated items.

The SLO Rule 416 does not have similar enhanced control techniques.

The VC rules have similar requirements on the freeboard ratio, the solvent ROC content (at 25 grams of ROC per liter), and the requirement for an automatic parts handling system. However, the vapor cleaner requirement specifies the use of at least one of these techniques (not both as in the SBC PAR 321): superheated vapor zones or refrigerated freeboard chillers.

The SJV Rule 4662 requires all cleaners subject to the rule to have a freeboard ratio of 1.0 or greater. SJV Rule 4662, Sections 5.1.2 requires cold cleaners to use a solvent with an ROC content of 25 g/l or less. Also, SJV Rule 4662, Sections 5.4.10 and 5.5.7 require the use of an automatic parts handling system, a superheated vapor zone, and a freeboard refrigeration device.

- Solvent ROC Content Limits. The SLO Rule 416 does not limit the solvent ROC content. The VC and SJV rules generally limit the solvent ROC content to 25 grams per liter for solvent cleaning machines and solvent cleaning. Both air districts provide exceptions to these limits. In general the SBC is taking the same approach, but with a solvent limit of 50 grams per liter.
- Solvent Cleaning Devices and Methods. The District modeled the proposed Rule 321, Section M.2 provisions on the requirements in SJV Rule 4663, Section 5.2 (Cleaning Methods) and, to a larger degree, on the VC Rule 74.6, Section B.2 (Cleaning Devices and Methods Requirements). However, SBC staff used most of the VC text verbatim as they had modified their rule to address EPA concerns. The SLO Rule 416 does not have similar provisions on solvent cleaning.

- Cleaning of Spray Application Equipment. PAR 321.M.3 will require the cleaning of spray application equipment to use:
 - 1. A cleaning solvent with an ROC content of 50 grams per liter or less, or
 - 2. An enclosed system (or equipment that is proven to the satisfaction of the Control Officer to equally effective as an enclosed system).

The SLO *degreasing operations* rule does not have specific requirements for the cleaning of application equipment. VC Rule 74.6 requires application equipment cleanup solvents to have 1) an ROC composite partial pressure no greater than 33 millimeters of mercury at 20 degrees Celsius and 2) an ROC content no greater than 900 grams per liter.

The application equipment cleaning requirements in SJV Rule 4663, Section 5.2.3, are essentially the same requirements proposed in the SBC revised Rule 321.

- Compliance Statement Requirement. The SJV Rule 4663, Section 6.1, and the VC 74.6, Section B.7, require the specification of the solvent's ROC content on the solvent container or a separate product sheet. The SBC PAR 321 and SLO Rule 416 do not have a similar requirement.
- Emission Control System Requirements. All of the adjoining air districts have provisions on emission control systems. However, the District's PAR 321.N.1 is the only rule provision to also require that TACs be controlled with an overall efficiency of 85 percent or greater.

VC Rule 74.6 and SJV Rule 4662 require an overall control efficiency of 85 percent. SJV Rule 4663 requires an overall control efficiency of 85.5 percent or 90 percent collection efficiency with an exhaust less than 50 ppmv of VOC. And the SLO Rule stipulates the control efficiency must be 95 percent (there is no collection efficiency).

Alternative Operating and Equipment Requirements for An Airless Solvent Cleaning Machine
or an Air-Tight Solvent Cleaning Machine. The PAR 321 includes an alternative compliance
method for airless or air-tight solvent cleaning machines.

The SLO rule does not include a similar provision. The two VC rules governing solvent cleaning and solvent cleaning machines provide for the use of an alternative cleaning system, provided that the system is approved by the APCO and EPA and the emission rate from the system are lower than the emission rate from complying with the other rule requirements.

The SJV Rule 4662, Section 5.6, provisions on the use of air-tight or airless cleaning systems are similar to the SBC PAR 321, Section O, provisions.

- **Test Methods.** The current and PAR 321 contain test methods, as do all of the adjoining air district solvent rules, except for SLO.
- Operation and Maintenance Plan. The requirement for an operation and maintenance plan is in the current and PAR 321. Under the SBC rule, these plans need to be developed and implemented when a source is using an emission control device. None of the adjoining air districts have a comparable requirement.
- Recordkeeping Requirements. Currently, the SBC Rule 321 recordkeeping provision requires quarterly records for sources having a solvent cleaning machine Permit to Operate. The APCD proposes to make the recordkeeping frequency monthly and expand the requirements to any person that uses a solvent cleaning machine or performs solvent cleaning that is subject to Rule 321. The SBC PAR 321 modified recordkeeping provision also includes requirements to:

- 1. Document the solvents' ROC content,
- 2. When performing solvent cleaning, keep track of the type of solvent cleaning activity performed (per the rule's Table 1 categories) and the solvent type used for the activity,
- 3. Specify the type of solvent cleaning machine used,
- 4. When using an emission control system, record key operating parameters,
- 5. When using aerosol products and claiming an exemption per Section B.9, maintain daily records on the solvent usage rates on a facility basis, and
- 6. Maintain monthly records on the solvent usage rates for sources claiming the PAR 321.B.15 exemption from the PAR 321.M.1 ROC limits.

The SLO rule does not include any recordkeeping provisions. The SJV recordkeeping provisions in their two solvent rules (4662 and 4663) are similar to the SBC PAR 321 recordkeeping requirements. However, the SJV Rule 4663 recordkeeping provisions do not include the documentation of aerosol product use because the rule does not include this exemption.

In general, the combined VC recordkeeping provisions from their two solvent rules are less rigorous then those in the PAR 321.

- **Reporting Requirements.** The SBC current and PAR 321 require the submittal of an annual report, but only for sources holding a permit for a solvent cleaning machine or solvent cleaning. None of the adjoining air districts require the submittal of annual reports.
- Compliance Schedule. The SJV Rules 4662 and 4663 included some new provisions with an effective date one year from the date of the rule amendment. VC adopted revisions to Rule 74.6 and the new Rule 74.6.1 on November 11, 2003 and made both of the rules effective July 1, 2004. The SLO Rule 416 was adopted June 18, 1979 with an effective date of January 1, 1980.

In general, the provisions in proposed amended Rule 321 will become effective on the date of rule adoption, with a few exceptions:

- The owners or operators of equipment becoming subject to Rule 321 due to a Rule 102, Rule 202, and/or Rule 321 change will have phased compliance periods, as specified in Rule 321, Section T.3.^a Similarly, any equipment previously subject to a Rule 321 exemption that is lost through the rule revisions will also have similar phased compliance deadlines per PAR 321.T.2.b.^b
- 2. Certain new provisions in Sections H through and including M provide for a one-year compliance deadline.^c

Click here to return to the list of Appendices in the Background Paper.

^a For example, existing solvent cleaning employing smaller containers (1 gallon capacity or less) subject to the PAR 202.U.1 permit exemption will need to comply with the Rule 321 provisions within the phased compliance period in Section T.3 (i.e., 180 days from the date of revised rule adoption).

^b For example, a remote reservoir cleaning machine that had been subject to the Rule 321.B.2 exemption will be required to comply with Rule 321 equipment provisions due to a loss in an exemption. Per PAR 321.T.2.b.3) the deadline to comply with the equipment requirements will be 365 days from the date of revised rule adoption.

^c Table 1 in Appendix E (page <u>E-3</u>) provides a summary of the provisions with a one-year deadline for compliance.



Appendix K Santa Barbara County Impacts from the Revised Rules

Industry Impacts

The impacts from the revised rule will depend on the type of parts, products, and equipment being cleaned and the cleaning processes being used. In general, the revised Rule 321 will require the use of solvents with an ROC content of 50 grams per liter or less, unless a solvent with a higher ROC content is necessary to achieve a higher degree of cleanliness. In which case, there will be a "not to exceed' limit of 900 grams of ROC per liter or an exemption from the solvent ROC content limit. Sources switching to aqueous solvents or detergents will likely see cost savings.

The following provides information on the impacts from the various rule revisions and data on the sources potentially impacted by the changes.

RULE 102, DEFINITIONS

The addition of some of the new Rule 102 terms (e.g., including *toxic air contaminant* text in the definition of *solvent*) coupled with other revisions to Rule 321 will cause equipment and operations to become subject to the Rule 321 requirements for the first time.

To be impacted by the combined effects of the Rule 102 *solvent* definition and the Rule 321.B.1 revisions, an existing SCM would need to employ a non-ROC solvent (or one with ROCs ≤ two percent by weight) that also has a TAC concentration above two percent by weight. Previously Rule 321-exempt SCMs and/or solvent cleaning operations may become subject to Rule 321 due to the new Rule 102 *solvent* definition and/or other revisions to Rule 321. SCMs and solvent cleaning operations employing a solvent that has either an ROC content or a TAC content above two percent by weight will be subject to Rule 321 (unless exempt by Rule 321.A and/or B).

Table 1 shows six compounds that are classified as being both a non-reactive organic compound and a toxic air contaminant. Any person subject to the PAR 321.A applicability provision that is using a Table 1 compound in a concentration greater than 2 percent in a SCM or when performing solvent cleaning will be subject to Rule 321 unless exempt per Rule 321, Section B.^a

Table 1. COMPOUNDS IDENTIFIED AS BEING BOTH A NON-ROC AND A TAC SOLVENT^b

COMPOUND	SOLVENT REGULATED BY 40CFR, PART 63, SUBPART T	CAS No.	ABBREVIATED OR POLLUTANT CODE	HIGH OR LOW VOLATILITY SOLVENT
tert-butyl acetate	N	540-88-5	TBAC	Н
methylene chloride, dichloromethane	Y	75-09-2	METH or DCM	Н
perchloroethylene, tetrachloroethylene	Y	127-18-4	PERC or PERCH	H or L ^c
1,1,2-trichloro-1,2,2-trifluoroethane	N	76-13-1	CFC-113	Н
1,1,1-trichloroethane; methyl chloroform	Y	71-55-6	TCA	Н
trichlorofluoromethane	N	75-69-4	CFC-11	Н

^a If the TAC is also a halogenated hazardous air pollutant (HAP) solvent used in a SCM, its HAP concentration would need to be five percent by weight or less to become subject to Rule 321. (Current Rule 321, Section B.4.e and PAR 321.B.5 provide exemptions to SCMs using HAP solvents that are subject to 40 CFR, Part 63, Subpart T.)

^b These are chemicals that the District has identified. There may be additional ones the District is unaware of.

^c Categorizing the solvent as a high or low volatility solvent is a function of the solvent's in-use temperature.

The PAR 102 also includes amendments to the *reactive organic compound* definition that are associated with a permit exemption (PAR 202.D.10.l). The following Rule 202 discussion provides more details on sources that will be impacted from the ROC definition change and the new Rule 202.D.10.l provision.

RULE 202, EXEMPTIONS TO RULE 201

There may be some permitting activities due to the new Rule 202.D.10.l provision, which is associated with the Rule 102 revised definition of ROC. Apparently Vandenberg Air Force Base (VAFB) is using more than 1 gallon per year of HFE-7100 in aerospace activities without the benefit of an Air Pollution Control District permit or written exemption. Revised Rule 202.D.10.l will clarify that such an operation needs an Authority to Construct and Permit to Operate. There may be additional sources using compounds subject to the new Rule 202.D.10.l provision. For example, any company using AsahiKlin AK-225 (HCFC-225ca and HCFC-225cb) in amounts exceeding one gallon per year per source that are not already subject to a District permit will need to submit an application.^a

The District is unaware of any other sources that will become subject to permitting due to the new Rule 202, Section D.10.1 provisions. Aside from the above-referenced VAFB situation and other sources that may be using a compound listed in PAR 202.D.10.1, the proposed revisions to the exemptions for solvent cleaning and SCMs are not anticipated to cause any additional permitting activities. Thus, there should be no significant permitting impacts to the regulated industry due to the Rule 202 revisions.

RULE 321, SOLVENT CLEANING MACHINES AND SOLVENT CLEANING

Impacts from the proposed amended Rule 321 may occur for several reasons (e.g., changes in the Rule 321 exemptions and/or changes to the operating, equipment, recordkeeping requirements). Sources may need to do the following:

- a. Revise a *solvent cleaning machine* configuration, operating method, and/or a solvent to comply with the rule provisions;
- b. Replace the solvent used in *solvent cleaning* with a lower ROC content solvent;
- c. Modify existing *solvent cleaning* techniques to be consistent with the new requirement (i.e., use sanctioned devices and methods);
- d. Implement recordkeeping for the first time; or
- e. Modify their existing recordkeeping procedures (e.g., it is to be performed on a monthly basis, additional data is to be maintained).

To determine the companies and agencies that may be impacted by these rulemaking actions, staff reviewed:

- APCD records for permitting and exempting solvent users and the APCD water-based cleaner rebate program,
- Phonebook listings, and
- Internet search engine listings.

Due to the ubiquitous nature of solvent use and the APCD permit-exempt status of many of the devices and operations, a comprehensive listing of all sources that may be impacted by the rule revision is not possible.

^a Lockheed Martin-Santa Barbara Focal Plane and Raytheon have permits for their vapor SCMs that use AsahiKlin AK-225 (PTO 10282 and 11326, respectively).

Tables 1 and 2 in Appendix B list the facilities and automobile repair shops that may be impacted by the rule revisions.^a

The following information describes the anticipated rule impacts to the owners and operators of 1) various solvent cleaning machines and 2) facilities performing solvent cleaning. This section does not include the *inline cleaning machines* category because the APCD is unaware of any current use of these machines in Santa Barbara County.

Batch Cleaning Machines (Sections D, E, G, H, I, and J)

Tables 2 and 3 list facilities that possibly use batch solvent cleaning machines (vapor and cold types).

Company **FID** Advanced Vision Science 02463 **Digital Instruments** 03858 Kilovac Corporation 01670 Lockheed Martin (Santa Barbara Focalplane) 09424 Microwave Applications Group 01820 Raytheon - Buildings B1, B2, B3, & B6 04140 (Infrared) Raytheon - Building B8 03890 Raytheon - Hollister (Electronic Warfare) 01971 Renco Encoders, Incorporated 04574 Special Technologies Laboratory 02758

Table 2. BATCH VAPOR CLEANING MACHINES

Vapor cleaning machines not otherwise exempt from the requirements will need to have a minimum freeboard ratio of 1.0 and automatic sump heat shut off devices for various operating conditions. In addition, any such machine that is employed with a solvent having an ROC content in excess of 50 grams per liter will need to have an automated parts handling system, circumferential trough, water separator, freeboard refrigeration device, and a superheated vapor zone. The installation of these devices on a currently permitted solvent cleaning machine will require the submittal of an Authority to Construct modification application.

Staff has not identified any permitted vapor cleaning machines that will need modifications under the proposed amended Rule 321. If a source needs to install a new device to comply with Rule 321, it will be impacted by the Authority to Construct (ATC) and Permit to Operate (PTO) application filing fees (currently \$335/application). In addition, the ATC and PTO fees will be assessed (on a reimbursable basis).

Owners and operators of vapor solvent cleaning machines needing to comply with the revised Rule 321 requirements may encounter retrofit costs on the order of those shown below.

^a Automobile repair shops are facilities that repair engines, transmissions, brakes and other similar components of motor vehicles and should not be confused with automobile body shops. Painting activities at body shops are regulated under Rule 339, Motor Vehicle and Mobile Equipment Coating Operations.

^b Unless the solvent cleaning machine is equipped with an APCD-approved emission control system or is subject to a Rule 321.B.18 or 20 exemption.

• Extending the freeboard: \$2,800^a

• Automated parts handing system (simple manually actuated hoist): \$2,348^b

Freeboard refrigeration device: \$12,632^b

Superheated vapor zones systems are relatively common on new solvent cleaning machines, but they may not be available as retrofits. Thus, sources using vapor cleaning machines with solvents above the 50 grams per liter threshold may need to replace their machines to comply with the revised rule requirements. Staff estimates the capital cost of a unit (using isopropyl alcohol-cyclohexane solvent mixture) may be on the order of \$159,500 (plus installation costs). In addition, the APCD estimates the annual solvent cost for such a unit is about \$413 per year.

Table 3. BATCH COLD CLEANING MACHINES^e

Company	FID
Advanced Vision Science	02463
Allergan Corporation	10084
Arguello, Inc., Platforms Harvest,	08013 -
Hermosa, and Hidalgo	08015
Bardex Corporation	01152
Celite Corporation	00012
DCOR, LLC., Platform A	08003
DCOR, LLC., Platform B	08004
DCOR, LLC., Platform C	08006
DCOR, LLC., Platform Habitat	08012
DCOR, LLC., Platform Henry	08007
DCOR, LLC., Platform Hillhouse	08005
Digital Instruments	03858
Dupont Displays	10307
Dupont Displays	08709
Essex Electronics, Inc.	01480
ExxonMobil Production Company, Las	01482
Flores Canyon	
ExxonMobil Production Company,	08018
Platform Harmony	
ExxonMobil Production Company,	08019
Platform Heritage	
ExxonMobil Production Company,	08009
Platform Hondo	02170
ExxonMobil Production Company,	03170
POPCO Plant Fortister Methons Crown LLC	09676
Fortistar Methane Group LLC	08676
Helix Medical, Incorporated	04487
Indigo Systems Corporation	09745

^a Staff used the freeboard extension cost estimate from the SCAQMD Staff Report for Proposed Amended Rule 1122, dated June 6, 1997, with a CPI adjustment (\$2,000/unit, 40.0% CPI increase).

^b Based on estimates in the VCAPCD Rule 74.6 Draft Staff Report dated July 10, 2003 (with a 17.4% CPI increase).

^c Reference, "Solvent Cleaning (Degreasing) An Assessment of Emission Control Options," November 1992, Center for Emissions Control, Inc., page 32.

^d Based on data in a Michigan Manufacturing Technology Center document titled, "Background Information - IPA-Cyclohexane Vapor Degreaser," 1999 (with a 37.5% CPI increase).

^e Includes remote reservoir batch cold cleaning machines.

	EID
Company	FID
International Transducer Co.	01634
Karl Storz Imaging, Incorporated	45883
Kilovac Corporation	01670
Lockheed Martin (Santa Barbara	09424
Focalplane)	
Medtronic PS Medical	04635
National Aeronautics & Space Admin.	06100
Pacific Hydraulic Systems	04617
Pacific Scientific, EKD	08934
Plains Exploration & Production	03095
Company, Lompoc Oil and Gas Plant	
Plains Exploration & Production	08016
Company, Platform Irene	
Raytheon	04140
Raytheon	01971
Raytheon	03890
Renco Encoders, Incorporated	04574
Skate One Corp.	03750
Spaceport Systems International	08698
Southern California Gas Company	01734
The Okonite Company	01900
Plains Exploration & Production	08016
Company, Platform Irene	
The Point Arguello Companies, Platform	08014
Hermosa	
The Point Arguello Companies, Platform	08015
Hidalgo	
Vandenberg Air Force Base	00201
6	(+ Others)

Depending on the items or parts being cleaned, batch cold cleaning machines (including remote reservoir batch cold cleaning machines) may need to be used with a solvent having an ROC content of 50 grams per liter or less. The cleaning of certain items (e.g., electronic components and medical devices) is exempt from the requirement that the solvent ROC content be limited to 50 grams per liter.

Some previously exempt *solvent wash stations* will become subject to the Rule 321 provisions for the first time.^a These units will need to comply with the general equipment requirements for solvent cleaning machines (Rule 321.G) and the additional equipment requirements for batch cold cleaning machines (Rule 321.I). And, if such a solvent wash station is used with a high volatility solvent, some of the things the owner or operator will need to make sure the equipment is equipped with or complies with include:

- 1. A cover that is a sliding, rolling, or guillotine type; designed to easily open and close (PAR 321.I.1).
- 2. A drainage apparatus or device, so the parts are under the cover while draining (PAR 321.I.2),
- 3. If the *freeboard ratio of 0.75* compliance option is employed (PAR 321.I.4), a maximum solvent fill mark, which complies with the freeboard ratio requirement (Rule 321.I.6), and

a"Solvent wash stations' include, but are not limited to, sinks and basins that typically contain unheated solvent used to clean parts and products by immersion and/or rinsing methods (batch cleaning mode). In general, such sinks and basins were subject to the Rule 321.B.2 exemption (capacity ≤ 1 gallon or evaporative surface area < 1 square foot; aggregate of such units < 10 square feet/stationary source). This exemption is deleted in the proposed amended Rule 321. However, a new provision (PAR 321.B.21) may provide limited exemptions for qualifying solvent wash stations.

4. A freeboard ratio of 0.75 (PAR 321.I.4) or alternative compliance requirement (PAR 321.I.5).

Solvent wash stations will need to use a solvent with a 50 grams per liter content (PAR 321.I.5) unless the process is exempt by a provision in PAR 321.B (e.g., PAR 321.B.8 or 21).

In general, one-third of the permitted cold solvent cleaning machines are used in the electronic or medical device manufacturing industries. Thus, these devices will not need to employ low-ROC solvents provided the solvents' ROC content does not exceed 900 grams per liter (per PAR 321.B.8).

The other two-thirds of the permitted batch cold SCMs and the area source (unpermitted) parts and brake washers (e.g., SCMs used by the automotive repair shops) will need to be converted to low-ROC solvents to comply with the revised rule (if they have not already switched over to aqueous or detergent-type cleaning solutions).

The APCD cost-estimates for replacing existing batch cold solvent cleaning machines with complying machines that use aqueous solvents or detergents are shown below.

Sink-on-a-drum	\$665–\$1,994 ^a
Enzyme system	\$1,329-\$1,994 ^a
Immersion Washer	
Spray Cabinet	\$2,658-\$7,974 ^a
Ultrasonic System	\$3,987-\$15,948°
Heated brake cleaner	
Unheated brake cleaner	
Birdbath brake cleaner	
Stand mounted brake cleaner.	

Generally, there are lower operating costs associated with aqueous cleaners. Thus, the equipment initial cost will be offset by lower operating costs.

Gas-Path Solvent Cleaners (Also Called "Corrosion Control Carts") (Sections D, G, and F)

These machines (or ancillary equipment) are used to clean the interiors of gas turbine or jet engines. The APCD has not identified any facilities that employ these cleaners that will be subject to the rule. Thus, there is no impact expected to this equipment category.

Air-Tight and Airless Solvent Cleaning Machines (Sections D and O)

Staff has identified only one facility with air-tight cleaning machines: Raytheon's Infrared facility (FID 4140). Table 4 lists the Raytheon air-tight solvent cleaning machines that will become subject to Rule 321.

^a Based on cost figures from the Institute for Research and Technical Assistance's Pollution Prevention Center document titled, "Switching to Water-Based Cleaners for Repair and Maintenance Parts Cleaning," CAL-EPA's Dept. of Toxic Substances Control Office of Pollution Prevention and Technology Development, Document No. 616, dated 1999 (with a CPI increase of 32.9%).

^b Based on cost figures from the Institute for Research and Technical Assistance's Pollution Prevention Center document titled, "Switching to Water-Based Cleaners for Automotive Brake Cleaning," CAL-EPA's Dept. of Toxic Substances Control Office of Pollution Prevention and Technology Development, Document No. 619a, dated 1999 (with a CPI increase of 32.9%).

Table 4. AIR-TIGHT SOLVENT CLEANING MACHINES THAT WILL BECOME SUBJECT TO RULE 321

Device Identification No.	Description
107323	TAS Automated Solvent Cleaner
108304	SSEC Solvent Cleaning Unit

Raytheon will need to ensure that these air-tight cleaning machines comply with the Rule 321, Section O provisions. There are no known impacts from Rule 321 becoming applicable to these units.

Solvent Cleaning (Section M)

Facilities that may be performing solvent cleaning that will become subject to Rule 321 are listed in Appendix B, Tables 1 and 2.^a

Depending on the general work surface category, items, products, or parts being cleaned, solvent cleaning will need to be performed with a solvent having an ROC content of 50 grams per liter or less. The proposed revised rule allows the use of solvents with higher ROC content when used in certain solvent cleaning categories (e.g., cleaning of electronic components or medical devices). Also, the revised rule will require that sanctioned cleaning devices and methods be used.

These requirements become effective one year after the date of adoption of the revised rule. The APCD proposes this compliance deadline to provide the regulated community adequate time to find suitable solvent replacements and/or make the necessary changes to the cleaning devices and methods to achieve compliance with the new provisions in Section M. For example, Helix Medical and Pacific Scientific will be subject to the Section M, Table 1, 900 g/l limits, but these sources are currently using solvents that exceed the limit. b It appears that these sources will be impacted by having to switch to compliant solvents.

Facilities complying with the 50 grams per liter limits (PAR 321.M.1, Table 1) for solvent cleaning should have an overall aggregate savings of about \$86,000 per year. c, d

The APCD is unaware of any impacts from the new Section M.2 (cleaning devices and methods) or Section M.3 (use of an enclosed gun washer or a cleaning material containing 50 grams per liter of ROC or less). Most facilities performing surface coating will be exempt from Section M.3 (per Section B.6). However, for cases where the spray gun cleaning is not exempt from Section M.3, the owners or operators may comply by switching to a low-ROC cleaning material.

The cost savings from changing to a cleaning material that contains 50 grams of ROC per liter or less would likely be on the order of \$0.75 per pound of ROC emissions reduced. If switching to a low-ROC cleaning material is infeasible, the cost for an enclosed spray gun washer is about \$1,900. The enclosed gun washer costs will be offset by reduced labor costs and reduced solvent costs (purchase and disposal).

^a Additional facilities may exist that perform solvent cleaning that will become subject to Rule 321 that the District is unaware of.

^b Helix Medical uses cyclohexanone (947 g/l) - FID 4487, DID 107500, process 0003. Pacific Scientific is using a solvent called "X-Caliber" (919 g/l) - FID 8934, DID 107600.

^c Based on a savings figure of \$1,325 per ton of ROC reduced for other solvent cleaning operations indicated in an EPA document titled, "Control Techniques Guidelines: Industrial Cleaning Solvents," EPA 453/R-06-001, September 2006 (with a CPI increase of 17%).

^d Also based on estimated 55.76 tons per year of ROC emission reduced for the 'handwiping' category.

^e EPA Proposed Rule, "National Emission Standards for Hazardous Air Pollutants: Paint Stripping and Miscellaneous Surface Coating Operations at Area Sources," 40CFR63, Draft of September 6, 2007.

New and Increased Recordkeeping and Reporting Impacts to the Owners and Operators (Sections R and S)

The APCD estimates that the average new costs for performing monthly recordkeeping will be about \$1,000 per facility per year for facilities becoming subject to Rule 321 for the first time (e.g., the facilities identified in Appendix B, Table 2). Staff estimate the average annual increased recordkeeping costs for the facilities listed in Appendix B, Table 1, will be \$700 per facility.

Facilities using aerosol products and claiming the Section B.9 exemption and sources using 55 gallons per year or less and claiming the Section B.15 exemption will need to maintain additional records on the solvent usage rates. The APCD anticipates that the administrative costs for substantiating these exemption claims will be \$500 per facility per year. A stationary source that has several facilities that is keeping records for the PAR 321.B.15 exemption will have higher recordkeeping costs compared to a stationary source with one facility.

There will likely be a slight increase in the administrative costs associated with preparing annual reports due to the change from quarterly to monthly recordkeeping and reporting. This increase only affects permitted facilities and the District estimates it will be on the order of \$200 to \$300 per facility.

District Impacts

There should be a minimal amount of application processing associated with the revised rules. The District has identified only one source that appears to need an Authority to Construct (ATC) and Permit to Operate (PTO) under the PAR 202.D.10.l provision for use of HFE-7100: Vandenberg Air Force Base. Staff has not identified any sources that will need an ATC or modified PTO due to SCM modifications required to comply with the PAR 321 requirements. Thus, the APCD is unaware of any pending applications to be submitted for equipment modifications due to the revised Rule 321 requirements.

The District anticipates that the majority of the staffing impacts from this rulemaking action will involve outreach and education efforts and enforcement activities. Inspection staff shall randomly spot-check unpermitted sources subject to the rule to ensure that they are complying with the appropriate provisions. These costs will be integrated into the APCD general compliance verification program.

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Appendix L Santa Barbara County Flowchart Overviews of Key Provisions of Proposed Amended Rule 202 and Rule 321

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321.B.1, B.2, B.3, B.4, B.5, and B.6	Figure 2. Rule 321, Section B, Exemptions for Solvent Cleaning Machines and Solvent Cleaning	<u>L-6</u>
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321.L.1, L.2, L.3, L4, L.5, and L.6	Figure L -11, Rule 321, Section L, Additional Equipment Requirements for In-Line Vapor Cleaning Machines	<u>L-23</u>
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Rule Section	Figure Title	Page
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321.N and Q	Figure 13, Rule 321, Section N, Emission Control System Requirements, and Section Q, Operation and Maintenance Plan	<u>L-29</u>
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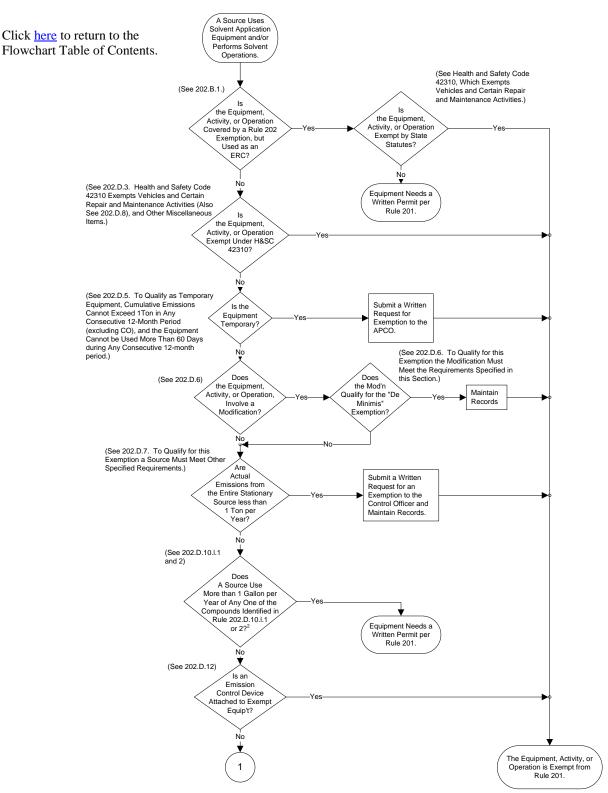


Figure 1. Rule 202 permit exemptions for solvent cleaning machines and solvent cleaning.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} Rule 202.D.10.l.1 includes the following compounds: dimethyl carbonate, methyl formate, HCFC-225ca, HCFC-225cb, HFC-43-10mee, HFC-365mfc, HFE-7100 ((CF $_3$) $_2$ CFCF $_2$ OCH $_3$), and HFE-7100 (C $_4$ F $_9$ OC $_2$ H $_5$). And Rule 202.D.10.l.2 addresses the use of tertiary-butyl acetate.

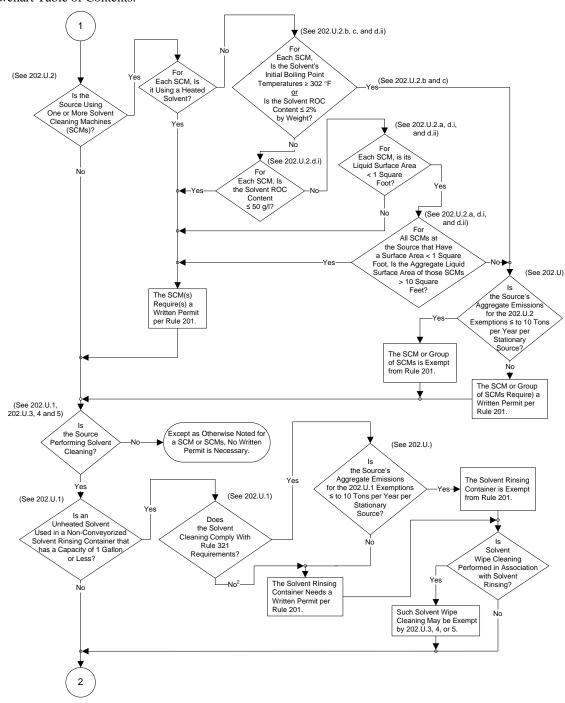


Figure 1. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} If the owner or operator revises the method of operation to conform to Rule 321 provisions and the APCO concurs that the source has achieved compliance with the Rule 321 requirements, the solvent cleaning will no longer be subject to permitting. Situations may arise where a Rule 202.U.1 exemption is not available because the solvent cleaning does not comply with Rule 321, but is brought into compliance through a modification, conditional abatement order, variance, permit condition, or other means. In which case, the owner or operator may request that the District review and determine if a permit or permit exemption is warranted under the current circumstances where solvent cleaning has been brought into compliance and will remain in compliance with Rule 321 requirements.

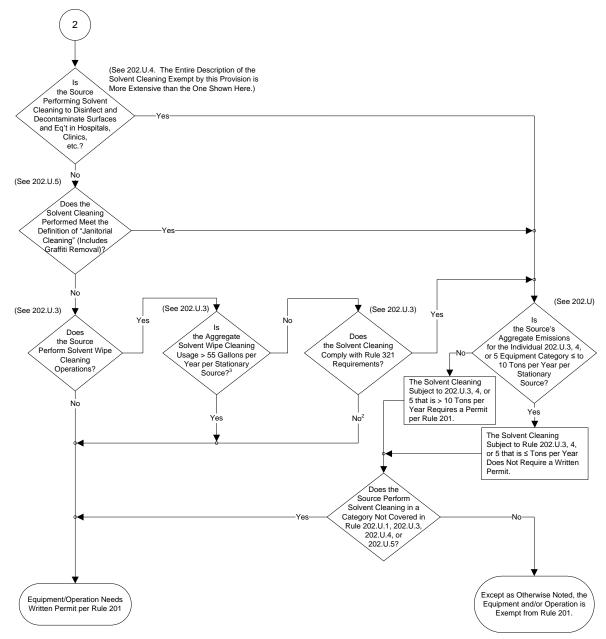


Figure 1. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} If the owner or operator revises the method of operation to conform to Rule 321 provisions and the APCO concurs that the source has achieved compliance with the Rule 321 requirements, the solvent cleaning will no longer be subject to permitting. Situations may arise where a Rule 202.U.3 exemption is not available because the solvent cleaning does not comply with Rule 321, but is brought into compliance through a modification, conditional abatement order, variance, permit condition, or other means. In which case, the owner or operator may request that the District review and determine if a permit or permit exemption is warranted under the current circumstances where solvent cleaning has been brought into compliance and will remain in compliance with Rule 321 requirements.

^{3.} Solvents meeting the requirements in 202.U.2.b or c or that have an ROC content ≤ 50 grams per liter do not contribute to the 55 gallons per year per stationary source permitting threshold aggregate figure.

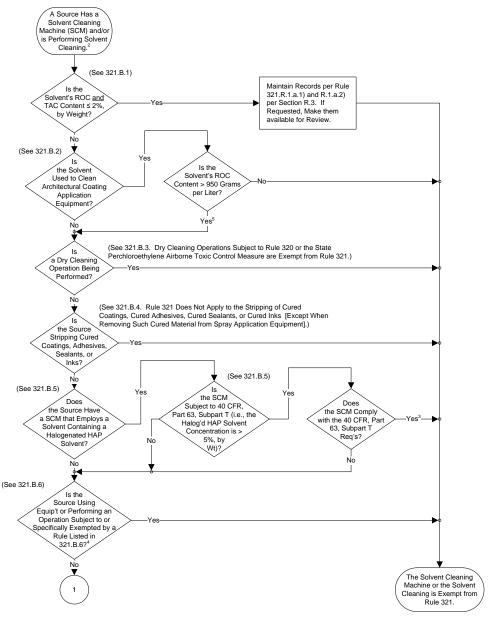


Figure 2. Rule 321, Section B, Exemptions for solvent cleaning machines and solvent cleaning.¹

4. The rules listed in 321.B.6 include:

Rule 325, Crude Oil Production and Separation.

Rule 326, Storage of Reactive Organic Compound Liquids.

Rule 330, Surface Coating of Metal Parts and Products.

Rule 337, Surface Coating of Metal Parts and Products.

Rule 337, Surface Coating of Aircraft or Aerospace Vehicle Parts and Products.

Rule 339, Motor Vehicle and Mobile Equipment Coating Operations.

Rule 343, Petroleum Sumps, Pits and Well Cellars.

Rule 349, Polyester Resin Operations.

Rule 351, Surface Coating of Wood Products.

Rule 353, Adhesives and Sealants.

Rule 343, Petroleum Surger Tank Degassing.

5. Additional information on eligibility for this exemption is presented in Figure 12, Page L-27, footnote 3.

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} Section A, Applicability, indicates that the rule applies to any person who owns, operates, or uses any solvent cleaning machine or performs any solvent cleaning outside of a solvent cleaning machine during the production, repair, maintenance, or servicing of parts, products, tools, machinery, equipment, or in general work areas at stationary sources.

^{3.} The Section B.5 provision prevails over the Section B.1 exemption. Thus, a SCM subject to and complying with 40 CFR, Part 63, Subpart T, is exempt irrespective that the unit uses a cleaning agent that contains more than 2 percent solvent that is a toxic air contaminant.

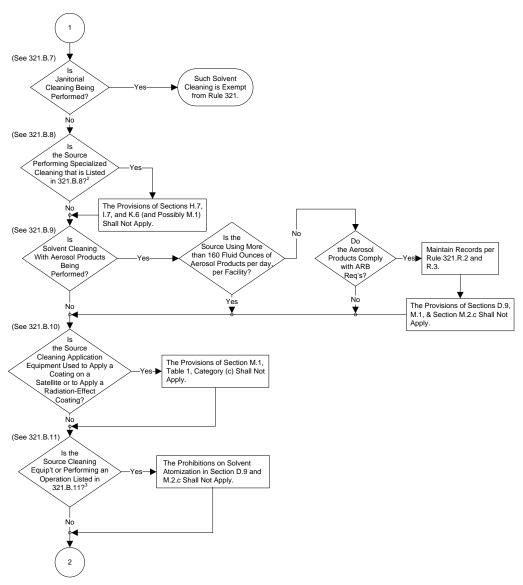


Figure 2. (cont.)¹

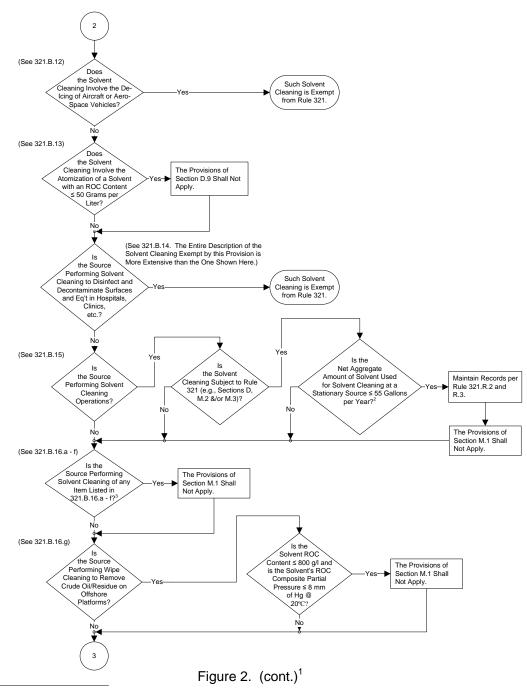
- Cleaning of solar cells, laser hardware, scientific instruments, high-precision optics, telescopes, microscopes, avionic equipment, and aerospace and military fluid systems.
- b. Cleaning in laboratory tests and analyses, including quality assurance and quality control applications, or bench scale or short-term (less than 2 years) research and development projects.
- c. Cleaning of cotton swabs to remove cottonseed oil before cleaning of high-precision optics.

In addition, the 321.H.7, 321.I.7, and 321.K.6 provisions do not apply to SCMs employed with solvents having 900 grams of reactive organic compound per liter of material or less used in the manufacturing, repairing, or maintenance of electrical apparatus components, electronic components, satellites, satellite components, aerospace vehicle payloads, aerospace vehicle payload components, medical devices, or silicone manufacturing.

- 3. Rule 321.B.11 provides exemptions from the 321.D.9 and 321.M.2.c prohibitions on solvent atomization for:
 - · Cleaning of the nozzle tips of automated spray equipment systems, except for robotic systems.
 - · Cleaning with hand-held spray bottles, squirt bottles, and other closed containers having a capacity of one liter or less.
 - Cleaning of gas turbines or jet engines using a gas-path solvent cleaner.

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} Rule 321.B.8 provides exemptions from the 321.H.7, 321.I.7, 321.K.6, and 321.M.1 provisions for the:



- 1. These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.
- 2. Solvents with a reactive organic compound content of 50 grams per liter of material or less do not count towards the exemption nonapplicability threshold limit.
- 3. 321.B.16.a f include the cleaning of:
- ultraviolet lamps used to cure ultraviolet inks coatings, adhesives, or resins.
- mold release compounds from molds.
- aerospace assembly and subassembly surfaces that are exposed to strong oxidizers or reducers such as nitrogen tetroxiode, liquid oxygen, or hydrazine.
- paper gaskets.
- clutch assemblies where rubber is bonded to metal by means of an adhesive.
- hydraulic actuating fluid from filters and filter housings.

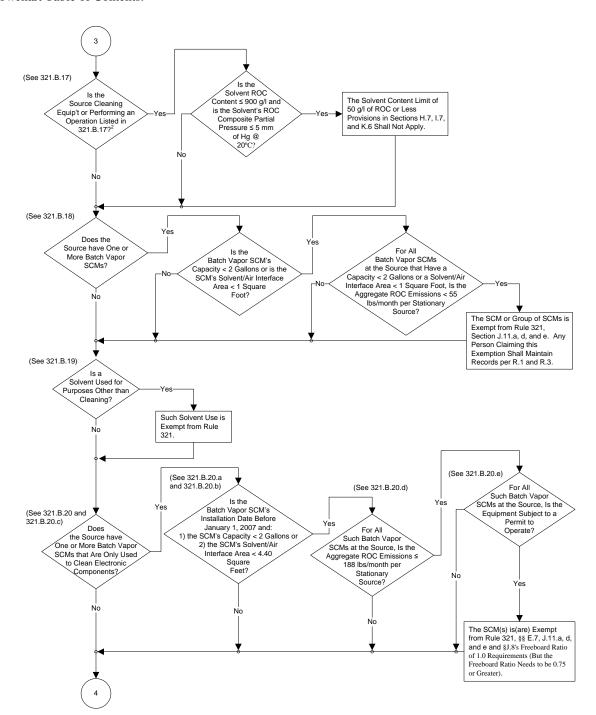


Figure 2. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} The activities identified in 321.B.17 include:

Manufacturing cleaning of nuts and bolts designed for automotive racing applications.

b. Cleaning of precision-lapped mechanical seals in pumps that handle liquefied gasses.

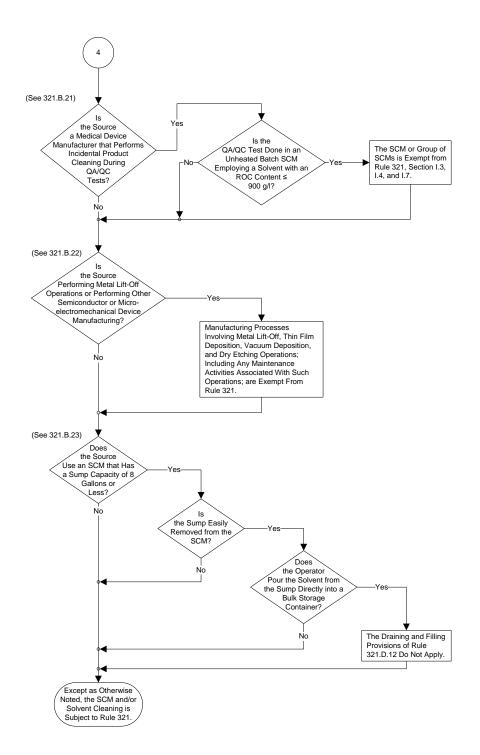


Figure 2. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

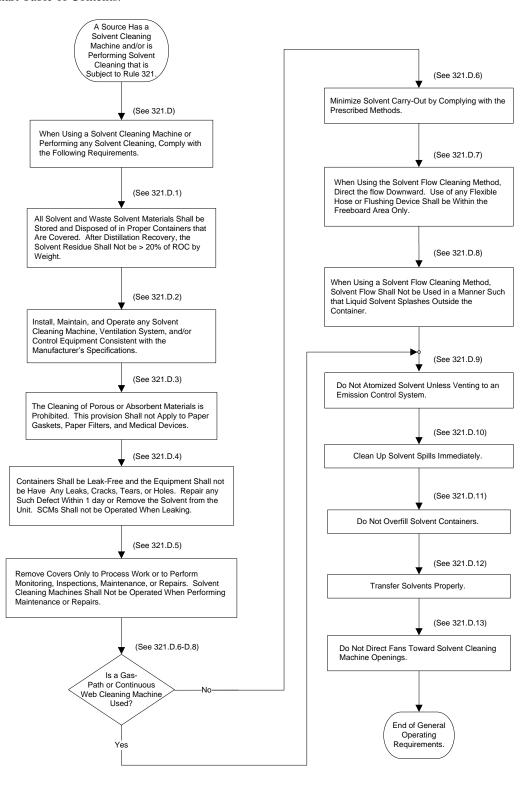


Figure 3. Rule 321, Section D, General operating requirements.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

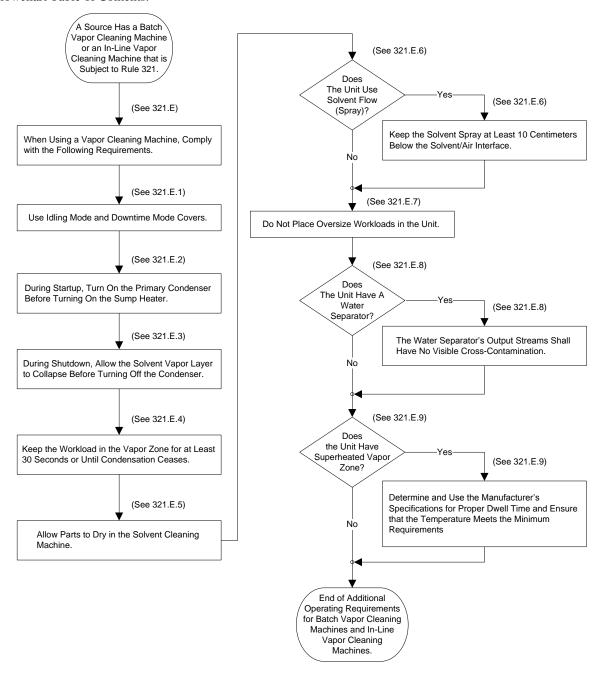


Figure 4. Rule 321, Section E, Additional operating requirements for batch vapor cleaning machines and in-line vapor cleaning machines.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

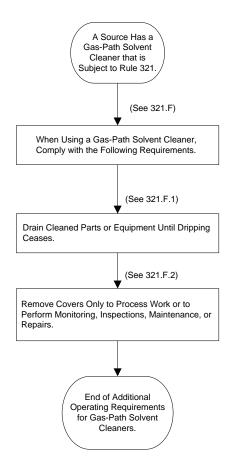


Figure 5. Rule 321, Section F, Additional operating requirements for gas-path solvent cleaners.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

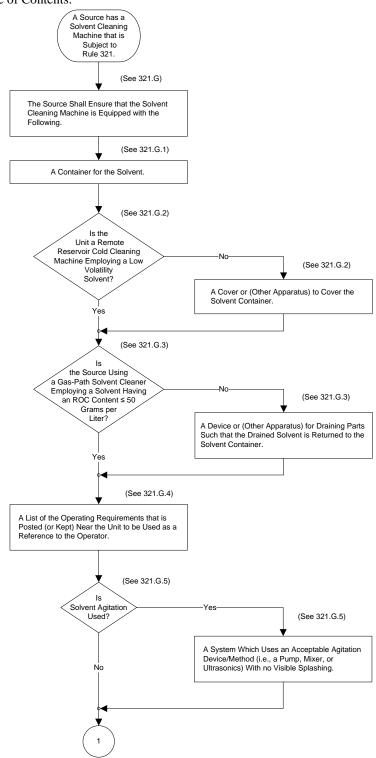


Figure 6. Rule 321, Section G, General equipment requirements for solvent cleaning machines.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

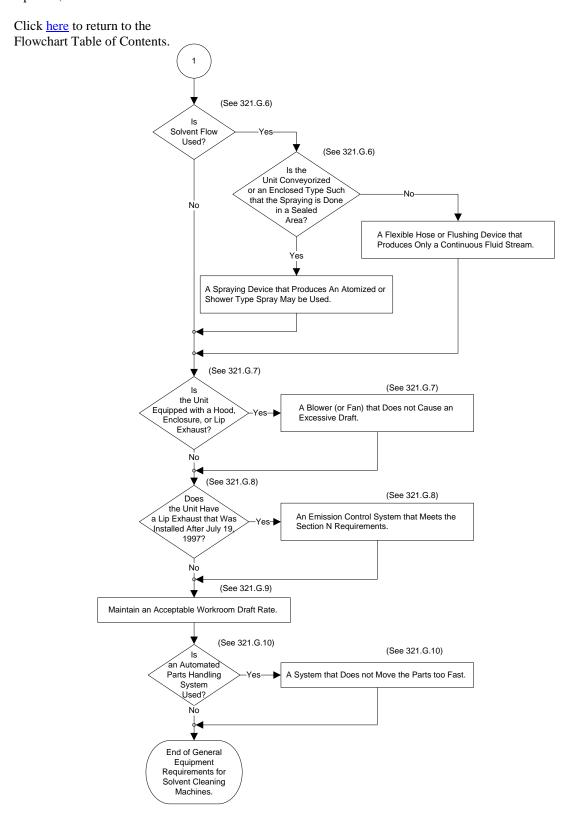


Figure 6. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

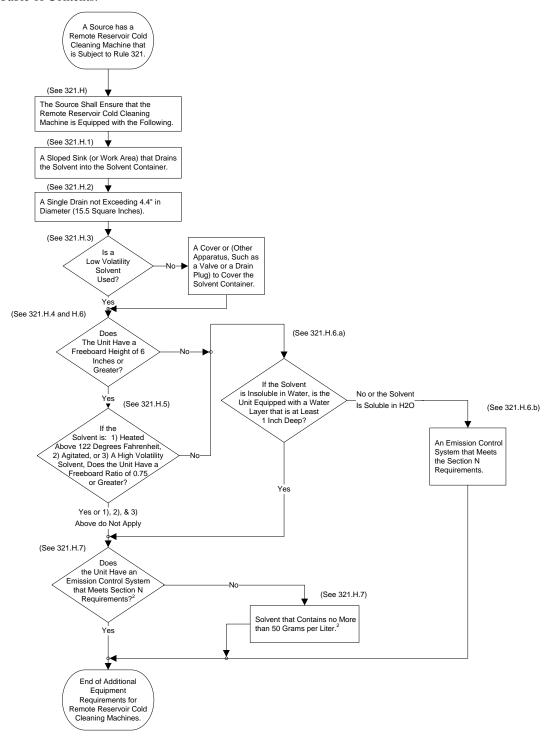


Figure 7. Rule 321, Section H, Additional equipment requirements for remote reservoir cold cleaning machines.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} This provision becomes effective one year from the date of the revised rule adoption.

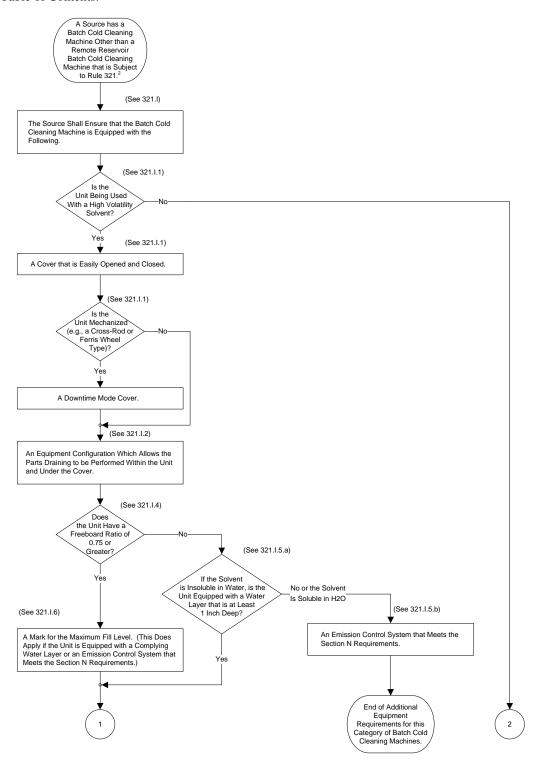


Figure 8. Rule 321, Section I, Additional equipment requirements for batch cold cleaning machines.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} A remote reservoir cold cleaning machine that uses an enclosed container that is accessible for dipping or soaking parts is also considered to be a batch cleaning machine and shall comply with the Section I requirements.

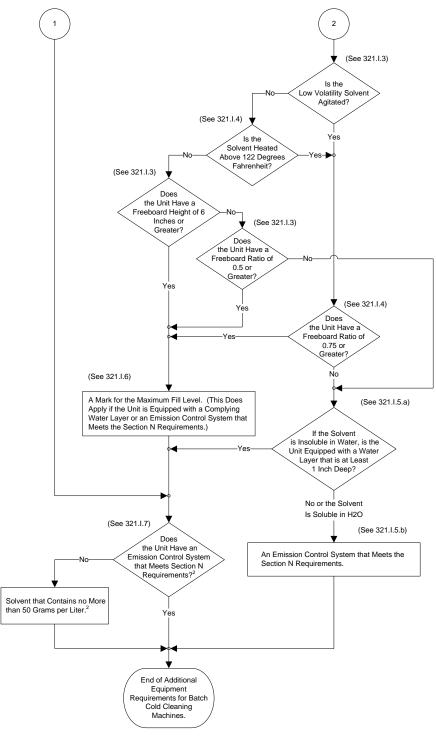


Figure 8. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} This provision becomes effective one year from the date of the revised rule adoption.

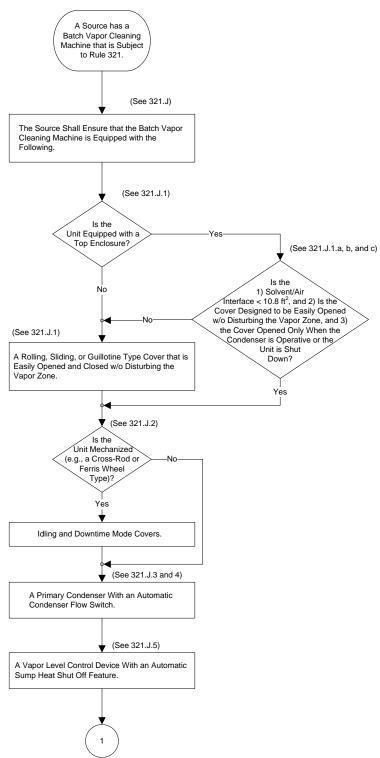


Figure 9. Rule 321, Section J, Additional equipment requirements for batch vapor cleaning machines.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

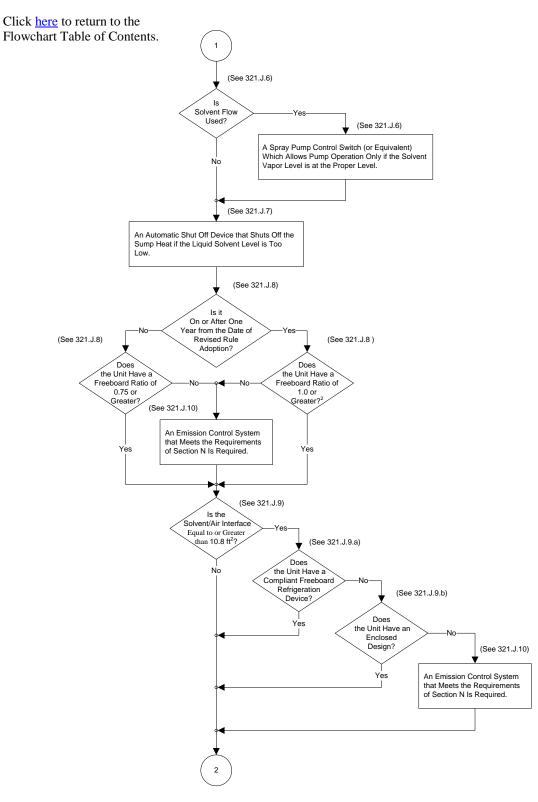


Figure 9. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} This provision becomes effective one year from the date of the revised rule adoption.

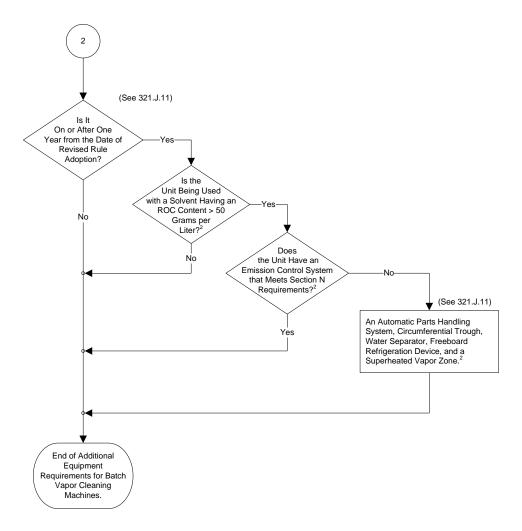


Figure 9. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} This provision becomes effective one year from the date of the revised rule adoption.

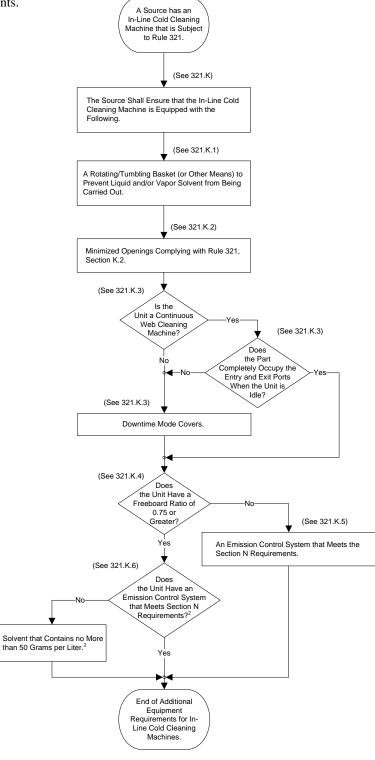


Figure 10. Rule 321, Section K, Additional equipment requirements for in-line cold cleaning machines.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} This provision becomes effective one year from the date of the revised rule adoption.

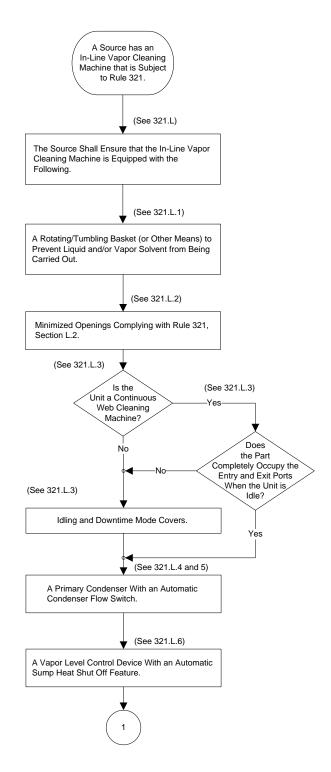


Figure 11. Rule 321, Section L, Additional equipment requirements for in-line vapor cleaning machines.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

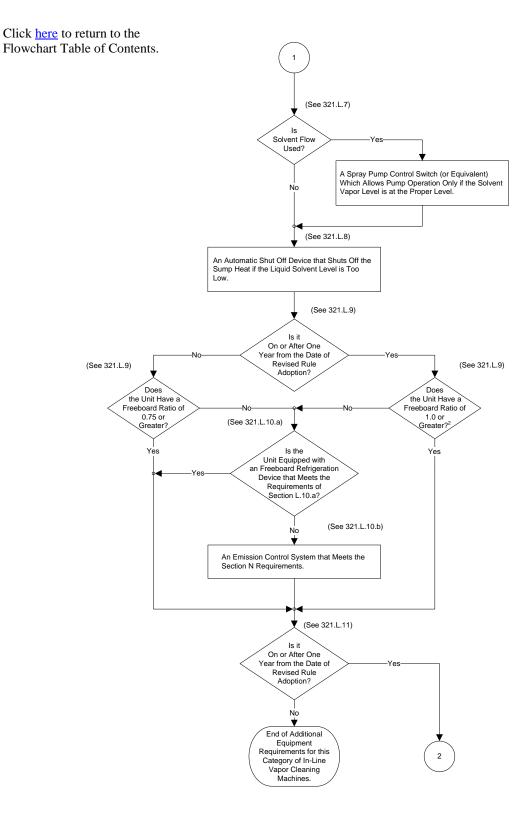


Figure 11. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} This provision becomes effective one year from the date of the revised rule adoption.

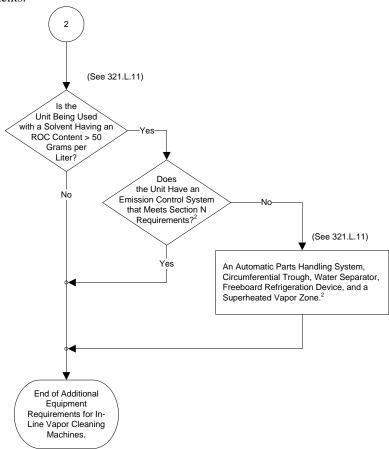


Figure 11. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} This provision becomes effective one year from the date of the revised rule adoption.

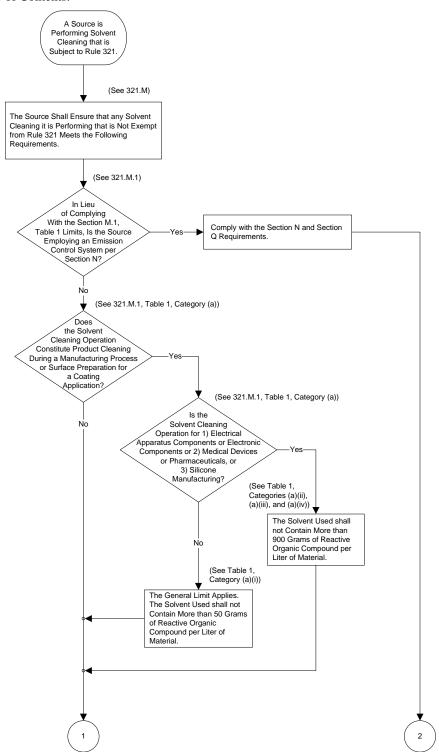


Figure 12. Rule 321, Section M, Requirements – solvent cleaning. 1, 2

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} The Section M provisions become effective one year from the date of the revised rule adoption.

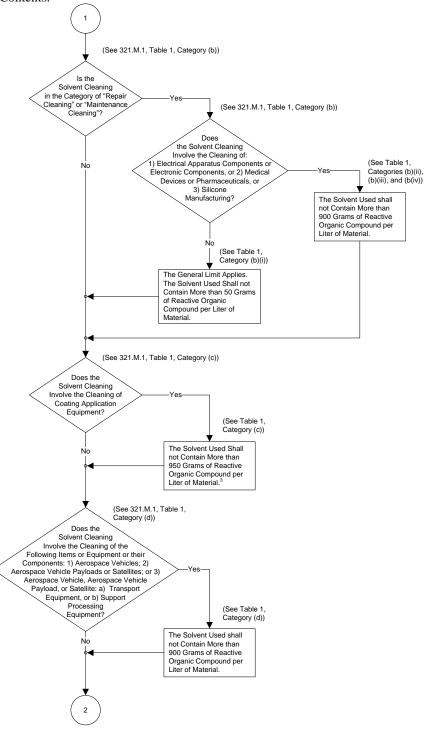


Figure 12. (cont.)^{1, 2}

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} The Section M provisions become effective one year from the date of the revised rule adoption.

^{3.} If the coatings application equipment is used to apply architectural coatings, use of a solvent with a 950 g/l or less ROC content makes such solvent cleaning eligible for the Rule 321.B.2 exemption.

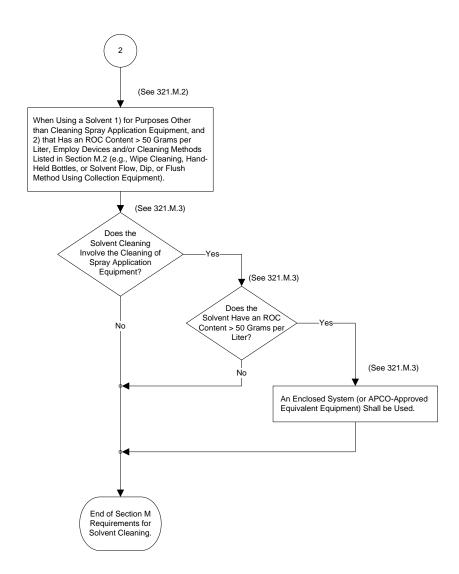


Figure 12. (cont.)^{1, 2}

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} The Section M provisions become effective one year from the date of the revised rule adoption.

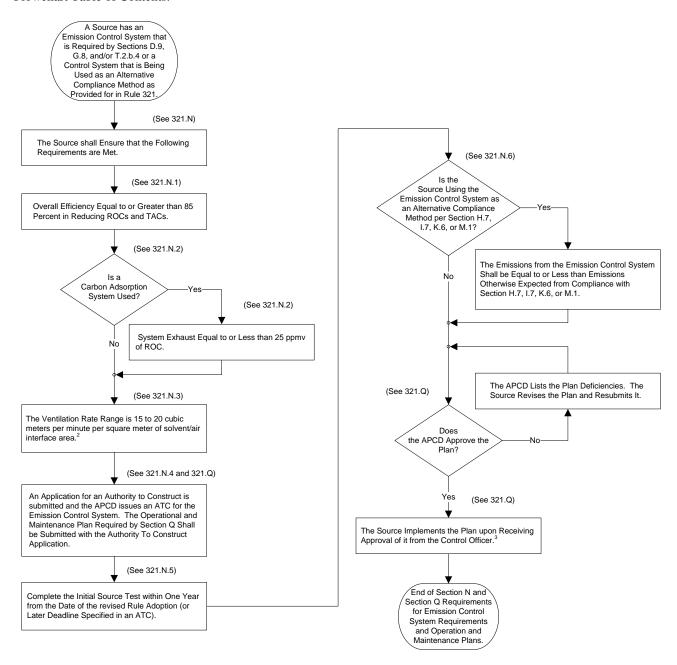


Figure 13. Rule 321, Section N, Emission control system requirements, and Section Q, Operation and maintenance plan.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} Unless otherwise required to meet a National Institute for Occupational Safety and Health Standard.

^{3.} The records required by the Operational and Maintenance Plan are to comply with the requirements in Sections R.1.c and R.3.

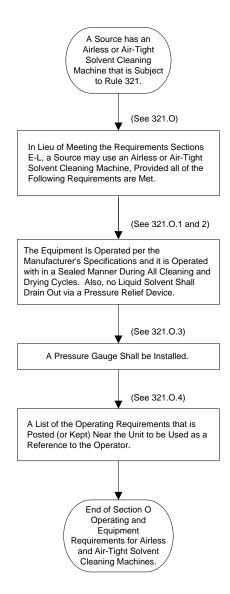


Figure 14. Rule 321, Section O, Alternative operating and equipment requirements for an airless solvent cleaning machine or an air-tight solvent cleaning machine.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

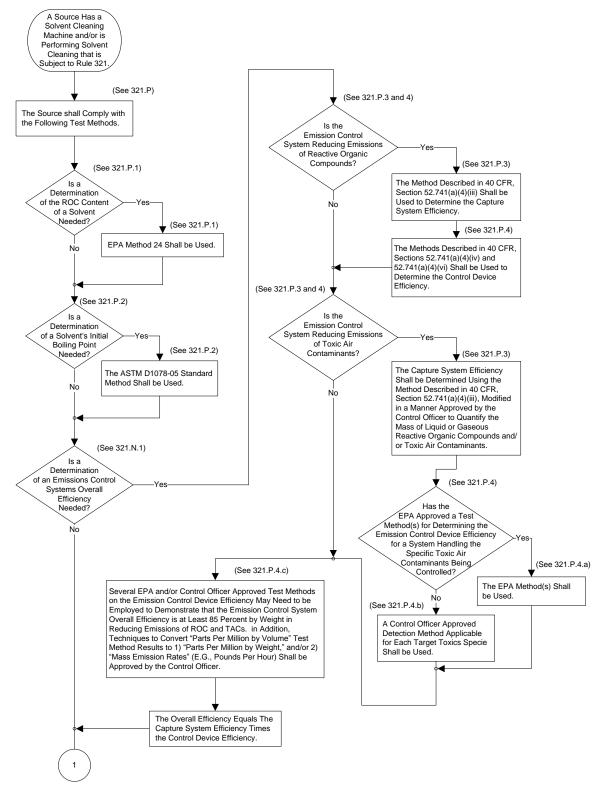


Figure 15. Rule 321, Section P, Test methods.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

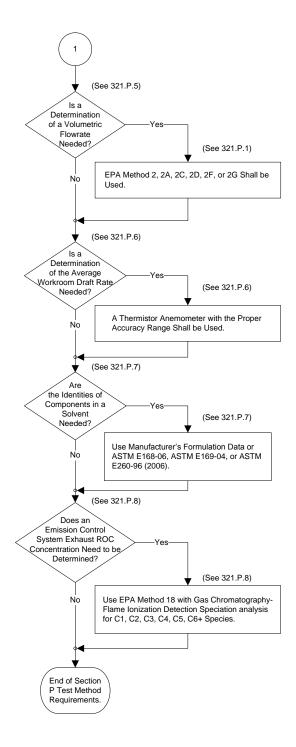


Figure 15. (cont.)¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

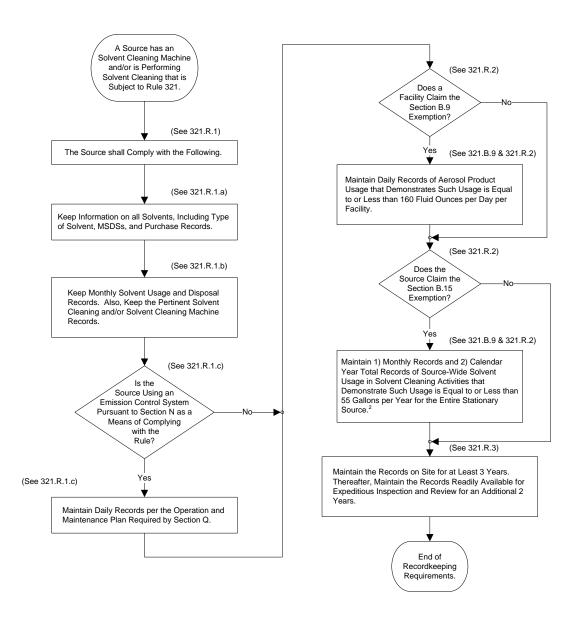


Figure 16. Rule 321, Section R, Recordkeeping requirements.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} Solvents with an ROC content of 50 grams per liter or less do not count toward the 55 gallons per year aggregate limit.

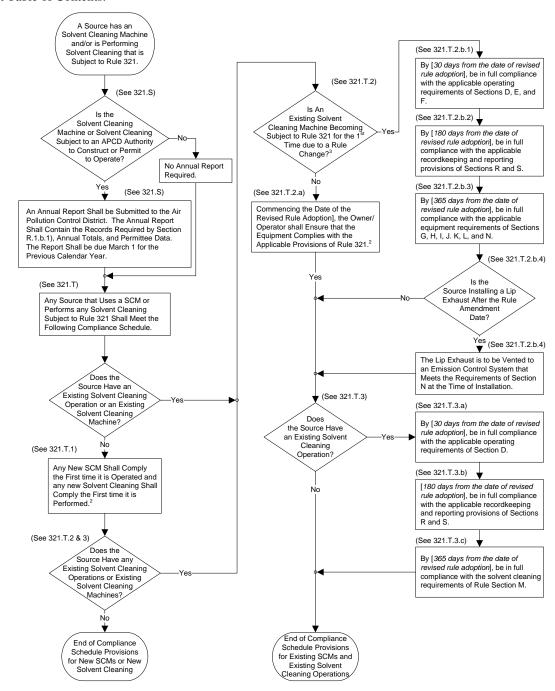


Figure 17. Rule 321, Section S, Reporting requirements, and Section T, Compliance schedule.¹

^{1.} These flowcharts are presented on an informational basis to assist the reader in understanding the requirements. If there is any conflict between the flowcharts and the rule, rule text takes precedent.

^{2.} The provisions in Sections H.7, I.7, J.8, J.11, K.6, L.9, and L.11 have an effective date of one year from the date of revised rule adoption.

^{3.} Some solvent cleaning machines have been exempt from the September 18, 1997 amended Rule 321, but will lose the exemption by the adoption of the proposed amended Rules 102 (Definitions), 202 (Exemptions to Rule 201), and/or Rule 321 (Solvent Cleaning and Solvent Cleaning Machines).

Solvent Cleaning Machine

("Solvent Cleaning Machine" is Defined in the Proposed Amended Rule 102. Definitions for the Different Types of Solvent Cleaning Machines are Found in Rule 321.C.)

Batch

Examples:

- 1. Immersion Cold Cleaner
- 2. Remote Reservoir Cold Cleaner
- 3. Solvent Wash Stations
- 4. Enclosed Gun Washer
- 5. Brake Cleaner
- 6. Parts Washer
- 7. Airless Solvent Cleaner
- 8. Airtight Solvent Cleaner
- 9. Open-top Vapor Cleaner
- 10. Gyro (Ferris Wheel) Vapor Cleaner²
- 11. Cross-Rod Vapor Cleaner²

In-Line or Continuous (Conveyorized) Cleaning Machine

Examples:3

- 1. Vibra Vapor Cleaner
- 2. Monorail Vapor Cleaner
- 3. Mesh Vapor Cleaner
- 4. Web Vapor Cleaner
- 5. Strip Vapor Cleaner
- 6. Coil Vapor Cleaner
- 7. Film Cleaner
- 8. Coil Cleaner
- 9. Wire Cleaner
- 10. Metal Strips Cleaner

Figure 18. Overview of the solvent cleaning machine categories.¹

Santa Barbara County APCD

Gas-Path Solvent Cleaner

Example:

Equipment that Applies Solvent to the Interior of Gas Turbine or Jet Engines.

²Provided the machine is manually or semi-continuously loaded.

³These machines use an automated parts handling system to provide a continuous supply of parts to be cleaned.

^{1.} This flowchart is presented on an informational basis to assist the reader in understanding the Rule 321 solvent cleaning machine categories. If there is any conflict between the flowchart and the rule, rule text takes precedent.

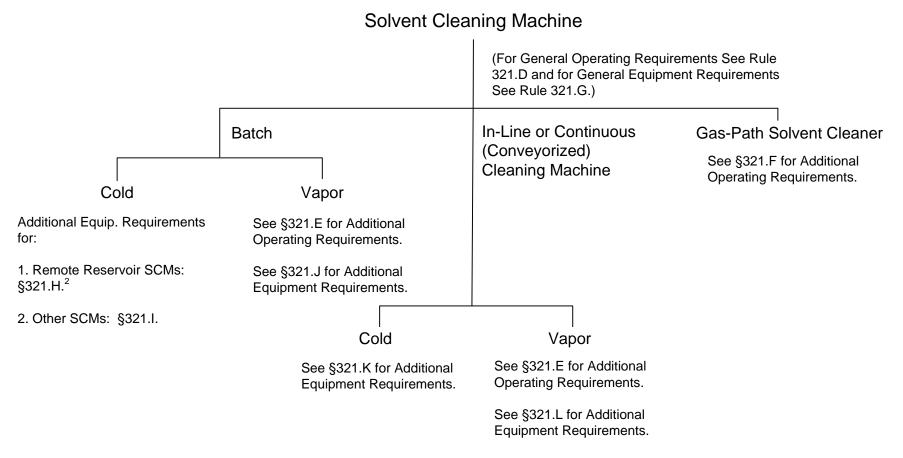


Figure 19, Overview of the Rule 321 equipment and operating requirement sections for the different types of solvent cleaning machines.¹

Click <u>here</u> to return to the list of Appendices in the Background Paper.

^{1.} This flowchart is presented on an informational basis to assist the reader in understanding the Rule 321 equipment and operating requirements. If there is any conflict between the flowchart and the rule, rule text takes precedent.

^{2.} A remote reservoir cold cleaning machine that uses an enclosed container that is accessible for dipping or soaking parts is also considered to be a batch cleaning machine and shall comply with the Section I requirements.

Appendix M Santa Barbara County List of Toxic Air Contaminants^a

	X	
Acetaldehyde		X
Acetamide	X	X
Acetonitrile	X	X
Acetophenone; Methyl phenyl ketone	X	X
2-Acetylaminofluorene [PAH-Derivative, POM]; N-fluoren-	X	X
2-yl acetamide		
Acrolein	X	X
Acrylamide	X	X
Acrylic acid	X	X
Acrylonitrile; Vinyl cyanide	X	X
Allyl chloride; 3-Chloropropene	X	X
Aluminum	X	
Aluminum oxide (fibrous forms)	X	
2-Aminoanthraquinone [PAH-Derivative, POM]	X	
4-Aminobiphenyl [POM]	X	X
Amitrole	X	
Ammonia	X	
Ammonium nitrate	X	
Ammonium sulfate	X	
Aniline	X	X
o-Anisidine	X	X
Anthracene [PAH, POM]	X	
Antimony	X	
Antimony compounds		X
Antimony compounds including but not limited to:	X	
Antimony trioxide		
Arsenic	X	
Arsenic compounds		X
Arsenic compounds (inorganic) including but not limited to: Arsine	X	

^a This table includes pollutants determined by the State Board to be a toxic air contaminant per Health and Safety Code sections 39655 and 39657. Any pollutants added to 1) the California Code of Regulations, Title 17, Sections 93000 and 93001, or 2) the *Consolidated Table of OEHHA/ARB Approved Risk Assessment Health Values* are also considered to be a toxic air contaminant by the Santa Barbara County Air Pollution Control District.

^b The AB 2588 Air Toxics "Hot Spots" Emission Inventory Criteria and Guidelines Regulation (Guidelines) provides direction and criteria to facilities on how to compile and submit air toxics emission data required by the "Hot Spots" Program. Appendix A-1 lists substances that must have the amount reported.

c "CCR" stands for California Code of Regulations. Sections 91300 and 91301 are found in Title 17, Division 3, Chapter 1, Subchapter 7.

^d Also identified as an EPA Hazardous Air Pollutant, promulgated under the provisions of the Clean Air Act Section 112(b).

COMPOUND	IN AB 2588	IN §93000	IN §93001
Arsenic compounds (other than inorganic)	X		
Arsenic, Inorganic, see Inorganic Arsenic		X	
Arsine	X		
Asbestos			X
Asbestos [asbestiform varieties of serpentine (chrysotile),		X	
riebeckite (crocidolite), cummingtonite-grunerite (amosite),			
tremolite, actinolite, and anthophyllite]			
Asbestos, see Mineral fibers (other than man-made)	X		
Barium	X		
Barium chromate	X		
Barium compounds	X		
Benz[a]anthracene [PAH, POM]	X		
Benzene	X	X	X
Benzidine (and its salts) [POM]	X		
Benzidine; 4-4'-diaminobiphenyl			X
Benzidine-based dyes [POM] including but not limited to:	X		
Direct Black 38 [PAH-Derivative, POM] Direct Blue 6			
[PAH-Derivative, POM] Direct Brown 95 (technical			
grade) [POM]			
Benzo[a]pyrene [PAH, POM]	X		
Benzo[b]fluoranthene [PAH, POM], see PAH	X		
Benzofuran	X		
Benzoic trichloride; Benzotrichloride	X		
Benzo[j]fluoranthene [PAH, POM]	X		
Benzo[k]fluoranthene [PAH, POM]	X		
Benzotrichloride			X
Benzoyl chloride	X		
Benzoyl peroxide; dibenzoyl peroxide	X		
Benzyl chloride, alpha-chlorotoluene	X		X
Beryllium, and beryllium compounds	X		
Beryllium compounds			X
Biphenyl [POM]; diphenyl; phenylbenzene	X		X
Bis(2-chloroethyl) ether; DCEE, see Dichloroethyl ether	X		
Bis(chloromethyl) ether, see bis-Chloromethyl ether	X		X
Bis(2-ethylhexyl)adipate	X		
Bis(2-ethylhexyl)phthalate (DEHP)	**		X
Bromine	X		
Bromine compounds (inorganic) including but not limited	X		
to:			
Bromine pentafluoride			
Hydrogen bromide Potassium bromate			
Bromine pentafluoride	X		
Bromoform; tribromomethane	X		X
1,3-Butadiene	X	X	X
2-Butanone, see Methyl ethyl ketone (MEK)	X	Λ	X
tert-Butyl acetate; tertiary-butyl acetate; t-Butyl acetate;	X		Λ
tBAc	Λ		
Butyl acrylate	X		
n-Butyl alcohol; 1-butanol	X		
sec-Butyl alcohol	X		
tert-Butyl alcohol	X		
Butyl benzyl phthalate	X		
Cadmium compounds	X		X
Cadmium (metallic cadmium and cadmium compounds)	Λ	X	Λ
Caumum (metame caumum and caumum compounds)		Λ	l

COMPOUND	IN AB 2588	IN §93000	IN §93001
Calcium cyanamide	X	0	X
Caprolactam	X		X
Captafol	X		
Captan	X		X
Carbaryl [PAH-Derivative, POM]; 1-naphthyl N-	X		X
methylcarbamate			11
Carbon black extracts	X		
Carbon disulfide	X		X
Carbon tetrachloride; Tetrachloromethane	X	X	X
Carbonyl sulfide	X		X
Carrageenan (degraded)	X		
Catechol; pyrocatecho	X		X
Chloramben	X		X
Chlordane; 1,2,44,5,6,7,8-octochloro-3a,4,7,7a-tetrahydro-	X		X
4,7-methanoindane	71		21
Chlorinated dibenzodioxins; dioxins; see Polychlorinated	X		
dibenzo-p-dioxins) [POM]	71		
Chlorinated paraffins (average chain length, C12;	X		
approximately 60% chlorine by weight)	71		
Chlorine	X		X
Chlorine dioxide	X		21
Chloroacetic acid	X		X
2-Chloroacetophenone	X		X
p-Chloroaniline	X		21
Chlorobenzene; monochlorobenzene	71		X
Chlorobenzenes including but not limited to:	X		X
Chlorobenzene Chlorobenzene	Α		Α
Dichlorobenzenes (mixed isomers) including:			
1,2-Dichlorobenzene			
1,3-Dichlorobenzene			
p-Dichlorobenzene; 1,4-Dichlorobenzene;			
1,4-Dichlorobenzene (p)			
1,2,4-Trichlorobenzene			
Chlorobenzilate [POM]; Ethyl-4,4'-dichlorobenzilate	X		X
Chlorodifluoromethane; Fluorocarbon 22	X		
Chloroform; trichloromethane	X	X	X
bis-Chloromethyl ether	X		X
Chloromethyl methyl ether			X
Chloromethyl methyl ether (technical grade)	X		_
Chlorophenols including but not limited to:	X		
2-Chlorophenol			
2,4-Dichlorophenol			
Pentachlorophenol			
Tetrachlorophenols including but not limited to:			
2,3,4,6-Tetrachlorophenol			
2,4,5-Trichlorophenol			
2,4,6-Trichlorophenol			
4-Chloro-o-phenylenediamine	X		
Chloropicrin; trichloronitromethane	X		
Chloroprene; 2-chloro-1,3-butadiene	X		X
p-Chloro-o-toluidine	X		
Chromium	X		
Chromium compounds			X
Chromium compounds (other than hexavalent)	X		_
Chromium, Hexavalent, see Hexavalent chromium (CR VI))		X	
, , , , , , , , , , , , , , , , , , , ,			1

COMPOUND	IN AB 2588	IN §93000	IN §93001
Chromium, hexavalent (and compounds) including but not	X	11 325000	11 (3) 3 0 0 1
limited to:	71		
Barium			
Calcium chromate			
Chromium trioxide			
Lead chromate			
Sodium dichromate			
Strontium chromate			
Chrysene [PAH, POM]	X		
Cobalt compounds	71		X
Cobalt	X		21
Cobalt compounds	X		
Coke oven emissions	X		X
	X		Λ
Copper and copper compounds Creosotes			
	X		
p-Cresidine	X		37
m-Cresol	X		X
o-Cresol	X		X
p-Cresol	X		X
Cresols (mixtures of); Cresylic acid; including:	X		
m-Cresol			
o-Cresol			
p-Cresol			
Cresols/Cresylic acid (isomers and mixture)			X
Crotonaldehyde	X		
Cumene; isopropylbenzene	X		X
Cumene hydroperoxide	X		
Cupferron	X		
Cyanide compounds			X
Cyanide compounds including but not limited to:	X		
Hydrocyanic acid			
Cyclohexane	X		
Cyclohexanol	X		
Cycloheximide	X		
2,4-D, salts and esters			X
DDE, see Dichlorodiphenyldichloroethylene			X
Decabromodiphenyl oxide [POM], see Polybrominated	X		
diphenyl ethers	71		
Dialkylnitrosamines including but not limited to:	X		
N-Nitrosodi-n-butylamine	71		
N-Nitrosodiethanolamine			
N-Nitrosodiethylamine			
N-Nitrosodimethylamine			
N-Nitrosodi-n-propylamine			
N-Nitrosomethylethylamine			
2,4-Diaminoanisole	X		
2,4-Diaminotoluene; 2,4-Toluenediamine; 2,4-Toluene	X	+	X
diamine	Λ		A
Diaminotoluenes (mixed isomers) including but not limited	X		X
to: 2,4-Diaminotoluene; 2,4-Toluenediamine	Λ		Λ
Diazomethane	X		X
	X	+	Λ
Dibenz[a,h]acridine [POM]			
Dibenz[a,j]acridine [POM]	X	+	
Dibenz[a,h]anthracene [PAH, POM], see PAH	X	-	
7H-Dibenzo[c,g]carbazole [PAH, POM], see PAH	X		

Diberzo(a,elpyrene [PAH, POM], see PAH	COMPOUND	IN AB 2588	IN §93000	IN §93001
Dibenzo[a.] pyrene [PAH, POM], see PAH	Dibenzo[a,e]pyrene [PAH, POM], see PAH	X		
Dibenzo al pyrene [PAH, POM], see PAH	Dibenzo[a,h]pyrene [PAH, POM], see PAH	X		
Dibenzo-p-dioxins and Dibenzofurans chlorinated in the 2,3,7 and 8 positions and containing 4,5,6 or 7 chlorine atoms Dibenzofurans (POMI Dibenzofurans Dibenzofurans Dibenzofurans Dibenzofurans Dibenzofurans Dibenzofurans X X X X X X X X X	Dibenzo[a,i]pyrene [PAH, POM], see PAH	X		
Dibenzo-p-dioxins and Dibenzofurans chlorinated in the 2,3,3 and 8 positions and containing 4,5,6 or 7 chlorine atoms Dibenzofurans (chlorinated), see Polychlorinated X Dibenzofurans (POM] Dibenzofuran [POM] X Dibenzofuran POM] X Dibenzofuran POM] X X X X X X X X X	Dibenzo[a,l]pyrene [PAH, POM], see PAH	X		
atoms			X	
atoms	2,3,7 and 8 positions and containing 4,5,6 or 7 chlorine			
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Dibenzofurans X				
1,2-Dibromo-3-chloropropane; DBCP	Dibenzofuran [POM]	X		
1,2-Dibromo-3-chloropropane; DBCP				X
2.3-Dibromo-1-propanol X X X X X X Dibutyl phthalate; Dibutyl sulfate X X X X X X X X X X X X X X X X X X X	1,2-Dibromo-3-chloropropane; DBCP	X		X
Dibutyl phthalate; Dibutylphthalate X				
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3,3'-Dimethyoxybenzidine X 4,6-Dinitro-o-cresol (and salts) X X 2,4-Dinitrophenol X X	Dimethyl phthalate	X		X
3,3'-Dimethyoxybenzidine X 4,6-Dinitro-o-cresol (and salts) X X 2,4-Dinitrophenol X X	Dimethyl sulfate; methyl sulfate	X		X
4,6-Dinitro-o-cresol (and salts) X X X 2,4-Dinitrophenol X X	3,3'-Dimethyoxybenzidine			X
2,4-Dinitrophenol X X		X		X
•		X		X
	1,6-Dinitropyrene [PAH-Derivative, POM]	X		

L8-Dinitroptone PAH-Derivative, POM X	COMPOUND	IN AB 2588	IN §93000	IN §93001
Dinitrotoluenes (mixed isomers) including but not limited to: 2.4-Dinitrotoluene 2.4-Dinitrotoluene 2.4-Dinitrotoluene 2.5-Dinitrotoluene 2.5-Dinitrotoluenene 2.5-Dinitrotoluenenenenenenenenenenenenenenenenenenen	1,8-Dinitropyrene [PAH-Derivative, POM]	X		
to: 2,4-Dinitrotoluene 2,6-Dinitrotoluene 1,4-Dioxans; 1,4-Diethyleneoxide Dioxins (Chlorinated dibenzodioxins) (see Polychlorinated dibenzo-p-dioxins) [POM] Diphenylhydantoin [POM] 1,2-Diphenylhydanzine [POM]; Hydrazobenzene X Dipropylene glycol Dipropylene glycol methyl ether X Dipropylene glycol methyl ether X Dis-sec-octyl phthalate; bis(2-ethylhexyl) phthalate; diethylhexylphthalate Environmental Tobacco Smoke X X Epichlorohydrin, 1-chloro-2,3 epoxypropane X X X Epichlorohydrin, 1-chloro-2,3 epoxypropane X X X Epicy resins X 1,2-Epoxybutane X X Ethyl acrylate Ethyl acrylate Ethyl chloride; chloroethane X Ethyl chloride; chloroethane X Ethyl -4,4-dichlorobenzilate (see Chlorobenzilate) X Ethylene dichlorode; 1,2-dichlroethane X Ethylene dibromide; 1,2-dichlroethane X Ethylene glycol dimethyl ether; 1,2-dienthoxyethane X Ethylene glycol dimethyl ether; 1,2-dienthoxyethane X Ethylene glycol monobutyl ether X Ethylene glycol monomethyl ether, see 2-Bethoxyethanol X Ethylene glycol monomethyl ether, see 2	2,4-Dinitrotoluene			X
2.4-Dinitrotoluene 1.4 Dioxane; 1.4-Diethyleneoxide 1.4 Dioxane; 1.4-Diethyleneoxide 1.5 Dioxins (Chlorinated dibenzo-dioxins) (see Polychlorinated dibenzo-dioxins) [POM] 1.2-Diphenylhydrazine [POM] 1.2-Diphenylhydrazine [POM]; Hydrazobenzene 1.2 X 1.2-Diphenylhydrazine [POM]; Hydrazobenzene 2. X 2. X 2. Dipropylene glycol methyl ether 2. X 3. X 3. X 4. X 4	Dinitrotoluenes (mixed isomers) including but not limited	X		
2.6-Dinitrotoluene 1.4-Dioxane; 1.4-Diethyleneoxide Noxane; 1.2-Diphenylhydrazine [POM] Noxane; 1.4-Diethyleneoxide Noxane; 1.2-Diphenylhydrazine [POM] Noxane; 1.4-Diethyleneoxide Noxane; 1.2-Diphenylhydrazine [POM]; Hydrazobenzene Noxane; 1.2-Diphenylhydrazine [POM]; Hydrazobenzene Noxane; 1.2-Diphenylhydrazine [PoM]; Hydrazobenzene Noxane; 1.2-Epoxypthalate Noxane; 1.2-Epoxypthalate Noxane; 1.2-Epoxypthalate Noxane; 1.2-Epoxybutane Noxane; 1.2-Ethyleneoxene Noxane; 1.2-Ethyleneoxeneoxeneoxeneoxeneoxeneoxeneoxeneo	to:			
J.A Dioxans: 1.4-Diethyleneoxide X	2,4-Dinitrotoluene			
Dioxins (Chlorinated dibenzodioxins) (see Polychlorinated dibenzop-dioxins) [POM] X X X X X X X X X	2,6-Dinitrotoluene			
dibenzo-p-dioxins) [POM] Diphenylhydantoin [POM] L2-Diphenylhydrazine [POM]; Hydrazobenzene X X X Dipropylene glycol Dipropylene glycol methyl ether Disec-octyl phthalate: bis(2-ethylhexyl) phthalate; X diethylhexylphthalate Environmental Tobacco Smoke Epichlorohydrin, 1-chloro-2,3 epoxypropane X X X Epixyl sersins X X L2-Epoxypustane X X X X Ethyl acrylate X X X X Ethyl acrylate X X X X Ethyl carbamate: Urethane X X X X Ethyl chloride; chloroethane X X X X Ethyl chloride; chloroethane X X X X Ethyl-4,4-dichlorobenzilate (see Chlorobenzilate) X Ethylene dibromide; 1,2 dibromochane X X X X Ethylene dibromide; 1,2 dichlorothane X X X X Ethylene dibromide; 1,2 dichlorothane X X X X Ethylene glycol dimethyl ether, 1,2 dicthoxyethane X X X X Ethylene glycol dimethyl ether; 1,2-dimethoxyethane, G-yme Ethylene glycol monoethyl ether, see 2-Ethoxyethanol X Ethylene glycol monoethyl ether, see 2-Ethoxyethanol X Ethylene glycol monomethyl ether, see 2-Ethoxyethanol X Ethylene glycol monomethyl ether see taketae X Ethylene glycol monomethyl ether, see 2-Ethoxyethanol X Ethylene glycol monomethyl ether, see 2-Ethoxyethanol X Ethylene glycol monomethyl ether seetate X Ethylene glycol monomethyl ether seetate X Ethylene glycol monomethyl ether seetate X X X X X X X X X X X X X X X X X X X	1,4 Dioxane; 1,4-Diethyleneoxide	X		X
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1.2-Diphenylhydrazine [POM]; Hydrazobenzene X Dipropylene glycol X Disec-octyl phthalate; bis(2-ethylhexyl) phthalate; X diethylhexylphthalate Environmental Tobacco Smoke X X X Epichlorohydrin, 1-chloro-2,3 epoxypropane X X X Epoxy resins X X 1,2-Epoxybutane X X X X Ethylaerylate X X X X Ethylaerylate X X X X X Ethylaerylate X X X X X Ethylearpamate; Urethane X X X X X Ethylearbamate; Urethane X X X X X Ethyl-chloride; chloroethane X X X X X X Ethylene dibromide; 1,2 dibromoehane X X X X X X X X X X X X X X X X X X X				
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Dispropylene glycol methyl ether X	1,2-Diphenylhydrazine [POM]; Hydrazobenzene	X		X
Di-sec-octyl phthalate; bis(2-ethylhexyl) phthalate; diethylhexylphthalate Six	Dipropylene glycol	X		
diethylhexylphthalate Environmental Tobacco Smoke Environmental Tobacco Smoke Expichlorohydrin, 1-chloro-2,3 epoxypropane X Epoxy resins 1,2-Epoxybutane X Epoxy resins X 1,2-Epoxybutane X Ethyl acrylate X Ethyl acrylate X Ethyl carbamate; Urethane X Ethyl carbamate; Urethane X Ethyl carbamate; Urethane X Ethyl-1-4,4-dichlorobenzilate (see Chlorobenzilate) X Ethyl-1-4,4-dichlorobenzilate (see Chlorobenzilate) X Ethylene dibromide; 1,2 dibromochane X Ethylene dibromide; 1,2 dibromochane X Ethylene dichloride; 1,2-dichlroethane X Ethylene glycol diethyl ether, 1,2 dicthoxyethane X Ethylene glycol dimethyl ether; 1,2-dimethoxyethane, G- yme Ethylene glycol monobutyl ether, see 2-Ethoxyethanol X Ethylene glycol monoethyl ether, see 2-Methoxyethanol X Ethylene glycol monoethyl ether, see 2-Methoxyethanol X Ethylene glycol monoethyl ether acetate X Ethylene glycol monomethyl ether X Ethylene flycol monomethyl ether X Ethyl	Dipropylene glycol methyl ether	X		
Environmental Tobacco Smoke Epichlorohydrin, 1-chloro-2,3 epoxypropane X X X Epichlorohydrin, 1-chloro-2,3 epoxypropane X X X 1,2-Epoxybutane X Ethyl acrylate X Ethyl acrylate X Ethyl carbamate; Urethane Ethylenobenzilate; Urethane Ethylenobenzilate (see Chlorobenzilate) Ethylene X Ethylene X Ethylene X Ethylene dichloride; 1,2 dibromochane Ethylene dibromide; 1,2 dibromochane X Ethylene dichloride; 1,2-dichlroethane X Ethylene glycol dimethyl ether, 1,2 dicthoxyethane X Ethylene glycol dimethyl ether, 1,2-dimethoxyethane, G-yme Ethylene glycol monobutyl ether Ethylene glycol monobutyl ether X Ethylene glycol monobutyl ether acetate X Ethylene glycol monobutyl ether X Ethylene glycol monomethyl ether acetate X Ethylene glycol monobutyl ether X Ethylene glycol monobutyl ether X Ethylene glycol monomethyl ether acetate X Ethylene glycol monomethyl ether X Ethylene glycol monomethyl	Di-sec-octyl phthalate; bis(2-ethylhexyl) phthalate;	X		
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1,2-Epoxybutane	Epichlorohydrin, 1-chloro-2,3 epoxypropane	X		X
1.2-Epoxybutane		X		
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Dichlorofluoromethane; Fluorocarbon 21 Trichlorofluoromethane; Fluorocarbon 11 Formaldehyde X X X				
Trichlorofluoromethane; Fluorocarbon 11 Formaldehyde X X X				
Formaldehyde X X X				
		X	X	X
	Furan	X		_

COMPOUND	IN AB 2588	IN §93000	IN §93001
Gasoline engine exhaust including but not limited to:	X		_
Gasoline engine exhaust (condensates &			
extracts)			
Gasoline engine exhaust, particulate matter			
Gasoline engine exhaust, total organic gas			
Gasoline Vapors	X		
Glutaraldehyde	X		
Glycol ethers			X
Glycol ethers and their acetates including but not limited to:	X		
Diethylene glycol			
Diethylene glycol dimethyl ether			
Diethylene glycol monobutyl ether			
Diethylene glycol monoethyl ether			
Diethylene glycol monomethyl ether			
Dipropylene glycol			
Dipropylene glycol monomethyl ether			
Ethylene glycol diethyl ether			
Ethylene glycol dimethyl ether			
Ethylene glycol monobutyl ether			
Ethylene glycol monoethyl ether			
Ethylene glycol monoethyl ether acetate; PGMEA			
Ethylene glycol monomethyl ether			
Ethylene glycol monomethyl ether acetate			
Ethylene glycol monopropyl ether			
Propylene glycol monomethyl ether Propylene glycol monomethyl ether acetate			
Triethylene glycol dimethyl ether			
Heptachlor; 1,4,5,6,7,8,8-hepta-chloro-3a,4,7,7a tetrahydro	X		X
4,7 methanoindene	71		71
1,2,3,4,6,7,8-Heptachlorodibenzofuran see Polychlorinated	X		
dibenzofurans	11		
1,2,3,4,7,8,9-Heptachlorodibenzofuran see Polychlorinated	X		
dibenzofurans			
1,2,3,4,6,7,8-Heptachlorodibenzo-p-dioxin see	X		
Polychlorinated dibenzo-p-dioxins			
Hexachlorobenzene	X		X
Hexachlorobutadiene	X		X
Hexachlorocyclohexanes (mixed or technical grade)	X		
including but not limited to:			
alpha-Hexachlorocyclohexane			
beta-Hexachlorocyclohexane			
Lindane; gamma-Hexachlorocyclohexane			
Hexachlorocyclopentadiene	X		X
1,2,3,4,7,8-Hexachlorodibenzofuran see Polychlorinated	X		
dibenzofurans			
1,2,3,6,7,8-Hexachlorodibenzofuran see Polychlorinated	X		
dibenzofurans			
1,2,3,7,8,9-Hexachlorodibenzofuran see Polychlorinated	X		
dibenzofurans			
2,3,4,6,7,8-Hexachlorodibenzofuran see Polychlorinated	X		
dibenzofurans			
1,2,3,4,7,8-Hexachlorodibenzo-p-dioxin see Polychlorinated	X		
dibenzo-p-dioxins			
1,2,3,6,7,8-Hexachlorodibenzo-p-dioxin see Polychlorinated	X		
dibenzo-p-dioxins			

COMPOUND	IN AB 2588	IN §93000	IN §93001
1,2,3,7,8,9-Hexachlorodibenzo-p-dioxin see Polychlorinated	X	22 (8/2 2 2 2	
dibenzo-p-dioxins			
Hexachloroethane; perchloroethane	X		X
Hexamethylene diisocyanate; HDI; Hexamethylene-1,6-			X
diisocyanate			
Hexamethylphosphoramide	X		X
Hexane	X		X
Hexavalent chromium (CR (VI))	X	X	
Hydrazine	X		X
Hydrobromic acid, see Hydrogen bromide	X		
Hydrochloric acid, see Hydrogen chloride	X		
Hydrocyanic acid (see Cyanide compounds)	X		
Hydrofluoric acid, see Hydrogen Fluoride	X		
Hydrogen bromide	X		
Hydrogen chloride; Muriatic acid; Hydrochloric acid	X		X
Hydrogen cyanide	X		
Hydrogen fluoride; Hydrofluoric acid			X
Hydrogen sulfide	X		
Hydroquinone; 1,4-benezendiol	X		X
Indeno[1,2,3-cd]pyrene [PAH, POM]	X		11
Inorganic Arsenic	21	X	
Inorganic lead, see Lead compounds (inorganic)	X	11	
Inorganic lead		X	
Iron pentacarbonyl	X	71	
Isocyanates including but not limited to: Hexamethylene-	X		
1,6-diisocyanate Methylene diphenyl diisocyanate [POM];	11		
MDI Methyl isocyanate Toluene-2,4-diisocyanate (see			
Toluene diisocyanates) Toluene-2,6-diisocyanate (see			
Toluene diisocyanates)			
Isophorone	X		
Isophorone; 3,5,5-trimethyl-2-cyclohexen-1-one			X
Isoprene, except from vegetative emission sources	X		
Isopropanol, see Isopropyl alcohol	X		
Isopropyl alcohol; isopropanol	X		
4,4'-Isopropylidenediphenol	X		
Lead	X		
Lead compounds (inorganic) including but not limited to:	X		
Lead acetate			
Lead chromate (see Chromium, hexavalent)			
Lead phosphate			
Lead subacetate			
Lead compounds (other than inorganic)	X		
Lead compounds			X
Lindane (mixed or technical grade); gamma-	X		
Hexachlorocyclohexane, see Hexachlorocyclohexanes			
Lindane (all isomers)			X
Maleic anhydride; cis-butenedioic anhydride	X		X
Manganese	X		
Manganese compounds	X		X
Mercury	X		
Mercury compounds			X
Mercury compounds including but not limited to:	X		
Mercuric chloride			
Methyl mercury; Dimethylmercury			
Methanol, see Methyl alcohol	X		X

COMPOUND	IN AB 2588	IN §93000	IN §93001
Methoxychlor [POM]	X		
Methoxychlor; 1,1,1-trichloro-2-2-bis(p-			X
methoxyphenyl)ethane			
Methyl alcohol; methanol	X		X
2-Methylaziridine; 2-Methyl aziridine; 1,2-Propyleneimine	X		
Methyl bromide; Bromomethane	X		X
Methyl chloride; Chloromethane	X		X
Methyl chloroform; 1,1,1 trichloroethane	X		X
3-Methylcholanthrene [PAH-Derivative, POM]	X		
5-Methylchrysene [PAH-Derivative, POM]	X		
4,4'-Methylene bis(2-chloroaniline) [POM]; MOCA	X		X
Methylene chloride; dichloromethane	X	X	X
4,4'-Methylenedianiline (and its dichloride) [POM]	X		
4,4'-Methylenedianiline; MDA; 4,4'-Methylene dianiline			X
Methylene diphenyl diisocyanate; MDI	X		X
Methyl ethyl ketone; MEK; 2-butanone; ethyl methyl ketone	X		X
Methyl hydrazine	X		X
Methyl iodide; Iodomethane	X		X
Methyl isobutyl ketone; Hexone; MIBK	X		X
Methyl isocyanate	X		X
2-Methyllactonitrile; Acetone cyanohydrin	X		Λ
	X		v
Methyl methacrylate; methyl 2 methyl 2 propenoate			X
2-Methylpyridine	X		37
Methyl tert-butyl ether; MTBE; Methyl t-butyl ether	X		X
Michler's ketone [POM]	X		
Mineral fibers (fine, manmade)	X		
Mineral fibers (fine, manmade) (fine mineral fibers which	X		
are manmade and are airborne particles of a respirable size			
greater than 5 microns in length, less than or equal to 3.5			
microns in diameter, with a length to diameter ratio of 3:1)			
including but not limited to:			
Ceramic fibers			
Glasswool fibers			
Rockwool fibers			
Slagwool fibers.	***		
Mineral fibers (other than manmade) including but not	X		
limited to:			
Asbestos			
Erionite			
Talc containing asbestiform fibers	37		
Molybdenum trioxide	X		***
Naphthalene [PAH, POM]	X		X
Nickel	X		
Nickel (metallic nickel and inorganic nickel compounds)		X	
Nickel carbonyl; NI (CO)4	X		
Nickel compounds			X
Nickel compounds including but not limited to:	X		
Nickel acetate			
Nickel carbonate			
Nickel carbonyl			
Nickel hydroxide			
Nickelocene			
Nickel oxide			
Nickel subsulfide			
Nickel oxide	X		

COMPOUND	IN AB 2588	IN §93000	IN §93001
Nickel refinery dust from the pyrometallurgical process	X		
Nitric acid	X		
Nitrilotriacetic acid	X		
Nitrobenzene	X		X
4-Nitrobiphenyl [POM]	X		X
6-Nitrochrysene [PAH-Derivative, POM]	X		
2-Nitrofluorene [PAH-Derivative, POM]	X		
Nitrogen mustard N-oxide	X		
4-Nitrophenol	X		X
2-Nitropropane	X		X
1-Nitropyrene [PAH-Derivative, POM]	X		
N-Nitrosodi-n-butylamine, see Dialkylnitrosamines	X		
N-Nitrosodi-n-propylamine, see Dialkylnitrosamines	X		
N-Nitrosodiethylamine	X		
N-Nitroso-n-methylurea			X
N-Nitrosodimethylamine			X
N-Nitrosodimethylamine, see Dialkylnitrosamines	X		
p-Nitrosodiphenylamine [POM]	X		
N-Nitroso-N-methylurea	X		
N-Nitrosomorpholine	X		X
N-Nitrosopiperidine	X		
N-Nitrosopyrrolidine	X		
1,2,3,4,6,7,8,9-Octachlorodibenzofuran [POM] see	X		
Polychlorinated dibenzofurans			
1,2,3,4,6,7,8,9-Octachlorodibenzo-p-dioxin [POM] see	X		
Polychlorinated dibenzo-p-dioxins			
Oleum, see Sulfuric acid and oleum	X		

COMPOUND	IN AB 2588	IN §93000	IN §93001
PAHs (Polycyclic aromatic hydrocarbons) [POM] including	X		22 (8) 2 2 2 2
but not limited to:			
PAHs, total, w/o individ. components reported			
[PAH, POM]			
PAHs, total, with individ. components also			
reported [PAH, POM]			
Acenaphthene [PAH, POM]			
Acenaphthylene [PAH, POM]			
Anthracene [PAH, POM]			
Benz[a]anthracene [PAH, POM]			
Benzo[a]pyrene [PAH, POM]			
Benzo[b]fluoranthene [PAH, POM]			
Benzo[e]pyrene [PAH, POM]			
Benzo[g,h,i]perylene [PAH, POM]			
Benzo[j]fluoranthene [PAH, POM]			
Benzo[k]fluoranthene [PAH, POM]			
Chrysene [PAH, POM]			
Dibenz[a,h]anthracene [PAH, POM]			
Dibenzo[a,e]pyrene [PAH, POM]			
Dibenzo[a,h]pyrene [PAH, POM]			
Dibenzo[a,i]pyrene [PAH, POM]			
Dibenzo[a,l]pyrene [PAH, POM]			
Fluoranthene [PAH, POM]			
Fluorene [PAH, POM]			
Indeno[1,2,3-cd]pyrene [PAH, POM]			
2-Methyl naphthalene [PAH, POM]			
Naphthalene [PAH, POM]			
Perylene [PAH, POM]			
Phenanthrene [PAH, POM]			
Pyrene [PAH, POM]			
PAH-Derivatives (Polycyclic aromatic hydrocarbon	X		
derivatives) [POM] including but not limited to those			
substances listed in appendix A with the bracketed			
designation [PAH-Derivative, POM])			
Parathion; o,o-diethyl o-(p-nitrophenyl) phosphorothioate	X		X
Particulate Emissions from Diesel-Fueled Engines	X	X	
1,2,3,7,8-Pentachlorodibenzofuran see Polychlorinated	X		
dibenzofurans			
2,3,4,7,8-Pentachlorodibenzofuran see Polychlorinated	X		
dibenzofurans			
1,2,3,7,8-Pentachlorodibenzo-p-dioxin see Polychlorinated	X		
dibenzo-p-dioxins			
Pentachloronitrobenzene; Quintobenzene	X		X
Pentachlorophenol; PCP			X
Peracetic acid	X		
Perchloroethylene; Tetrachloroethylene; Tetrachloroethene	X	X	X
Phenol	X		X
p-Phenylenediamine			X
p-Phenylenediamine	X		
2-Phenylphenol [POM]	X		
Phosgene; carbonyl chloride, COCl2	X		X
Phosphine; PH3			X
Phosphorus	X		X

COMPOUND	IN AB 2588	IN §93000	IN §93001
Phosphorus compounds:	X		
Phosphine			
Phosphoric acid			
Phosphorus oxychloride			
Phosphorus pentachloride			
Phosphorus pentoxide			
Phosphorus trichloride			
Tributyl phosphate			
Triethyl phosphine			
Trimethyl phosphate			
Triorthocresyl phosphate [POM]			
Triphenyl phosphate [POM]			
Triphenyl phosphite [POM]			
Phthalic anhydride	X		X
·	Λ		X
Polychlorinated biphenyls (Aroclors)	***		X
Polychlorinated biphenyls (PCBs) [POM] including but not	X		
limited to:			
3,3',4,4'-Tetrachlorobiphenyl (PCB 77)			
3,4,4',5-Tetrachlorobiphenyl (PCB 81)			
2,3,3',4,4'-Pentachlorobiphenyl (PCB 105)			
2,3,4,4',5-Pentachlorobiphenyl (PCB 114)			
2,3',4,4',5-Pentachlorobiphenyl (PCB 118)			
2,3',4,4',5'-Pentachlorobiphenyl (PCB 123)			
3,3',4,4',5-Pentachlorobiphenyl (PCB 126)			
2,3,3',4,4',5-Hexachlorobiphenyl (PCB 156)			
2,3,3',4,4',5'-Hexachlorobiphenyl (PCB 157)			
2,3',4,4',5,5'-Hexachlorobiphenyl (PCB 167)			
3,3',4,4',5,5'-Hexachlorobiphenyl (PCB 169)			
2,3,3',4,4',5,5'-Heptachlorobiphenyl (PCB 189)			
Polychlorinated dibenzo-p-dioxins; PCDDs or Dioxins	X		
[POM] including but not limited to:			
Dioxins, total, w/o individ. isomers reported; PCDDs			
[POM]			
Dioxins, total, with individ. isomers also reported; PCDDs			
[POM]			
2,3,7,8-Tetrachlorodibenzo-p-dioxin; TCDD [POM]			
1,2,3,7,8-Pentachlorodibenzo-p-dioxin [POM]			
1,2,3,4,7,8-Hexachlorodibenzo-p-dioxin [POM]			
1,2,3,6,7,8-Hexachlorodibenzo-p-dioxin [POM]			
1,2,3,7,8,9-Hexachlorodibenzo-p-dioxin [POM]			
1,2,3,4,6,7,8-Heptachlorodibenzo-p-dioxin [POM]			
1,2,3,4,6,7,8,9-Octachlorodibenzo-p-dioxin [POM]			
Total Tetrachlorodibenzo-p-dioxin [POM]			
Total Pentachlorodibenzo-p-dioxin [POM]			
Total Hexachlorodibenzo-p-dioxin [POM]			
Total Heptachlorodibenzo-p-dioxin [POM]			

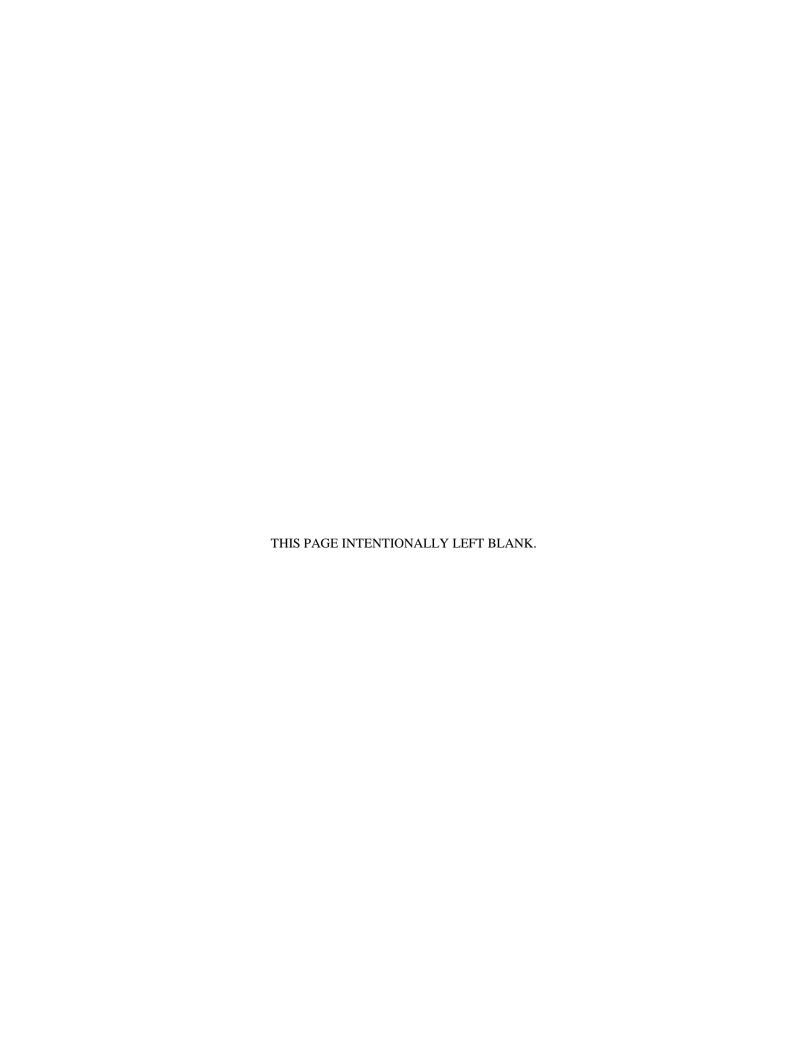
COMPOUND	IN AB 2588	IN §93000	IN §93001
Polychlorinated dibenzofurans; PCDFs or Dibenzofurans	X		_
[POM] including but not limited to:			
Dibenzofurans (Polychlorinated dibenzofurans); PCDFs			
[POM]			
2,3,7,8-Tetrachlorodibenzofuran [POM]			
1,2,3,7,8-Pentachlorodibenzofuran [POM]			
2,3,4,7,8-Pentachlorodibenzofuran [POM]			
1,2,3,4,7,8-Hexachlorodibenzofuran [POM]			
1,2,3,6,7,8-Hexachlorodibenzofuran [POM]			
1,2,3,7,8,9-Hexachlorodibenzofuran [POM]			
2,3,4,6,7,8-Hexachlorodibenzofuran [POM]			
1,2,3,4,6,7,8-Heptachlorodibenzofuran [POM]			
1,2,3,4,7,8,9-Heptachlorodibenzofuran [POM]			
1,2,3,4,6,7,8,9-Octachlorodibenzofuran [POM]			
Total Tetrachlorodibenzofuran [POM]			
Total Pentachlorodibenzofuran [POM]			
Total Hexachlorodibenzofuran [POM]			
Total Heptachlorodibenzofuran [POM]			
Polycyclic Organic Matter			X
POM; Polycyclic organic matter, including but not limited	X		Λ
to those substances listed in Appendix A with the bracketed	Λ		
designation of [POM], [PAH, POM], or [PAH-Derivative,			
POM])			
Potassium bromate	X		
1,3-Propane sultone	X		X
beta-Propiolactone	X		X
Propionaldehyde	X		X
Propoxur; 2-isopropoxyphenyl N-methyl carbamate;	X		X
Baygon	71		71
Propylene	X		
Propylene dichloride; 1,2-dichloropropane	X		X
Propylene oxide; 1,2-epoxy-propane	X		X
1,2-Propyleneimine; 2-Methyl aziridine; 2-Methylaziridine	X		X
Pyridine	X		
Quinoline	X		X
Quinone	X		X
Radionuclides (including radon)			X
Radionuclides including but not limited to:	X		
Iodine-131			
Radon and its decay products			
Reserpine [POM]	X		
Residual (heavy) fuel oils	X		
Selenium	X		
Selenium compounds including but not limited to:	X		
Hydrogen selenide			
Selenium sulfide			
Selenium compounds, as Se			X
Silica, crystalline	X		
Silver	X		
Silver compounds	X		
Sodium hydroxide, caustic soda	X		
Styrene	X		X
Styrene oxide	X		X
Sulfuric acid and oleum	X		
Sulfuric acid	X		
Terephthalic acid	X		
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COMPOUND	IN AB 2588	IN §93000	IN §93001
2,3,7,8-Tetrachlorodibenzofuran see Polychlorinated	X		
dibenzofurans			
2,3,7,8-Tetrachlorodibenzo-p-dioxin see Polychlorinated	X		X
dibenzo-p-dioxins			
1,1,2,2-Tetrachloroethane; acetylene tetrachloride	X		X
Tetrachloroethylene, see Perchloroethylene		X	X
Thallium	X		
Thallium compounds	X		
Thioacetamide	X		
Thiourea	X		
Titanium tetrachloride	X		X
Toluene; toluol	X		X
Toluene-2,4-diisocyanate; TDI; 2,4-Toluene diisocyanate	X		X
Toluene-2,6-diisocyanate	X		11
2,4-Toluenediamine; 2,4-Toluene diamine; see 2,4-	X		X
Diaminotoluene and Diaminotoluene	71		74
2,4-Toluenediamine, see Diaminotoluene	X		
Toluene diisocyanates including but not limited to:	X		
Toluene-2,4-diisocyanate	Λ		
Toluene-2,6-diisocyanate			
o-Toluidine; o-methylaniline	X		X
Toxaphene; Polychlorinated camphenes	X		Λ
Toxaphene; Chlorinated camphene Toxaphene; Chlorinated camphene	Λ		X
	X		Λ
Tributyl phosphate	Λ		V
1,2,4-Trichlorobenzene	V		X
1,1,1-Trichloroethane, see Methyl chloroform	X		X
1,1,2-Trichloroethane; vinyl trichloride	X	37	X
Trichloroethylene; trichloroethene	X	X	X
Trichlorofluoromethane; Fluorocarbon 11	X		***
2,4,5-Trichlorophenol	X		X
2,4,6-Trichlorophenol (see Chlorophenols)	X		X
1,2,3-Trichloropropane	X		
Triethylamine	X		X
Triethylene glycol dimethyl ether; Triglyme	X		
Trifluralin	X		X
1,2,4-Trimethylbenzene	X		
Trimethylbenzenes including but not limited to:	X		
1,2,4-Trimethylbenzene			
2,2,4-Trimethylpentane	X		X
Triorthocresyl phosphate [POM]	X		
Triphenyl phosphate [POM], TPP	X		
Urethane; Ethyl carbamate	X		
Vanadium (fume or dust)	X		
Vanadium Pentoxide	X		
Vinyl acetate	X		X
Vinyl bromide; bromoethylene	X		X
Vinyl chloride; Chloroethene	X	X	X
4-Vinylcyclohexene	X		
Vinyl fluoride	X		
Vinylidene chloride; 1,1-dichloroethylene	X		X
Wood preservatives (containing arsenic and chromate)	X		
Xylenes (isomers and mixture)			X
J (1	1	

COMPOUND	IN AB 2588	IN §93000	IN §93001
Xylenes (mixed xylenes) including:	X		
m-Xylene			
o-Xylene			
p-Xylene			
m-Xylenes			X
o-Xylenes			X
p-Xylenes			X
Zinc	X		
Zinc compounds including but not limited to:	X		
Zinc oxide			

Click <u>here</u> to return to the list of Appendices in the Background Paper.



Appendix N Santa Barbara County Solvent Information Table^a

ITEM	CHEMICAL OR PRODUCT (vapor pressure for select chemicals and products)	MOLECULAR FORMULA OR CHEMICAL FAMILY	ROC	ROC Content, grams per liter (lbs/gal)	SUBJECT TO 40CFR, PART 63, SUBPART T	CAS No.	ABBREVIATED OR POLLUTANT CODE	TACb	IBP° (°F)	HIGH OR LOW VOLATILITY SOLVENT ^d
1	acetic acid (11.3 mm of Hg @ 20° C)	C ₂ H ₄ O ₂	Y	1,048 (8.75)	N	64-19-7		N	244	Н
2	acetone	C ₃ H ₆ O	N	0 (0)	N	67-64-1		N	132	Н
3	acetonitrile	C_2H_3N	Y	785 (6.56)	N	75-05-8	MeCN	Y	179	Н
4	AsahiKlin AK- 225R	C ₃ HCl ₂ F ₅ & C ₃ HCl ₂ F ₅ [HCFC-225ca] & HCFC-225cb]	N ^e	0 (0)	N	422-56-0 39.6-49.5% & 507-55-1 49.5-59.4%	AK-225	N	129	Н

^a The Santa Barbara County Air Pollution Control District (District) solvent information table is provided for informational purposes only and in no way endorses any of the products. Data shown in the table may have changed due to product reformulation. Interested parties should check with the product manufacturers and/or suppliers for the most current data. The South Coast Air Quality Management District (SCAQMD) maintains a list of certified Clean Air Solvent (CAS) Products and Companies (http://www.aqmd.gov/rules/cas/prolist.html). Other companies may also market zero- or low-ROC solvents that may not be listed on the SCAQMD website.

- 1. $\leq 248 \, {}^{\circ}\text{F} \text{ or}$
- 2. > 248 °F, but the in-use temperature is not ≤ 212 °F below the IBP temperature.

Likewise, a "low volatility solvent" is any solvent with an IBP temperature > 248 °F and that has an in-use temperature that is ≤ 212 °F below the IBP temperature.

^b A "Y" (yes) indication means the chemical or product is a toxic air contaminant (TAC), as determined by the State Board per Health and Safety Code sections 39655 and 39657. Any pollutants added to 1) the California Code of Regulations, Title 17, Sections 93000 and 93001, or 2) the *Consolidated Table of OEHHA/ARB Approved Risk Assessment Health Values* are also considered to be a toxic air contaminant by the District.

^c IBP stands for "initial boiling point."

^d For solvent cleaning machine requirements, a "high volatility solvent" is any solvent with an IBP temperature:

^e This product is made up of materials listed in the proposed amended Rule (PAR) 102 definition of reactive organic compound as exempt compounds (non-ROC). Thus for the purpose of Rule 321, it will be treated as an exempt solvent (i.e., containing no ROCs). Per PAR 202.D.10.l, use of more than 1 gallon per year per stationary source requires an Authority to Construct and Permit to Operate. Some Asahi Glass Company AsahiKlin AK-225 solvents contain ROCs (e.g., AsahiKlin AK-225AES, AsahiKlin AK-225ATE).

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ITEM	CHEMICAL OR PRODUCT (vapor pressure for select chemicals and products)	MOLECULAR FORMULA OR CHEMICAL FAMILY	ROC	ROC Content, grams per liter (lbs/gal)	SUBJECT TO 40CFR, PART 63, SUBPART T	CAS No.	ABBREVIATED OR POLLUTANT CODE	TACb	IBP° (°F)	HIGH OR LOW VOLATILITY SOLVENT ^d
5	benzene	C_6H_6	Y	878 (7.33)	N	71-43-2		Y	176	Н
6	benzonitrile	C ₆ H ₅ CN	Y	999 (8.34)	N	100-47-0		N	370	L (if not heated)
7	2-butoxyethanol	$C_6H_{14}O_2$	Y	899 (7.51)	N	111-76-2	BuOX, BG	N	340	L (if not heated)
8	n-butyl acetate, butyl ethanoate	$C_6H_{12}O_2$	Y	879 (7.34)	N	123-86-4		N	259	Н
9	tert-butyl acetate (40 mm of Hg @ 25° C)	$C_6H_{12}O_2$	Y & N ^f	0 (0)	N	540-88-5	tBAc	Y	208	Н
10	n-butyl alcohol, 1-butanol, n- butanol	$C_4H_{10}O$	Y	809 (6.76)	N	71-36-3		Y	244	Н
11	tert-butyl alcohol	$C_4H_{10}O$	Y	785 (6.56)	N	75-65-0		Y	180	Н
12	carbon tetrachloride	CCl ₄	Y	1,583 (13.21)	Y	56-23-5	CT	Y	170	Н
13	chlorobenzene	C ₆ H ₅ Cl	Y	1,109 (9.26)	N	108-90-7		Y	268	Н
14	1-chlorobutane	C ₄ H ₉ Cl	Y	879 (7.34)	N	109-69-3		N	174	Н
15	chloroform, trichloromethane	CHCl ₃	Y	1,479 (12.34)	Y	67-66-3		Y	142	Н
16	cyclohexane	C_6H_{12}	Y	778 (6.50)	N	110-82-7		Y	177	Н
17	cyclohexanone	$C_6H_{10}O$	Y	947 (7.90)	N	108-94-1		N	312	Н
18	decamethylcyclopentasiloxane	$C_{10}H_{30}O_{5}Si_{5}$	N	0 (0)	N	541-02-6	DMCPS, D-5	N	410	L (if not heated)
19	1,2-dichlorobenzene, ortho- dichlorobenzene	C ₆ H ₄ Cl ₂	Y	1,299 (10.84)	N	95-50-1		Y	177	Н
20	1,1-dichloroethylene, vinylidene chloride	C ₂ H ₂ Cl ₂	Y	1,217 (10.16)	N	75-35-4	1,1-dce	Y	89	Н
21	1,2-dichloroethylene, ethylene dichloride	C ₂ H ₄ Cl ₂	Y	1,252 (10.45)	N	107-06-2	EDC	Y	182	Н

^f Consistent with 40CFR 51.100 tert-butyl acetate shall be considered exempt as a reactive organic compound only for purposes of reactive organic compound emissions limitations or reactive organic compound content requirements and will continue to be a reactive organic compound for purposes of all recordkeeping, emissions reporting, photochemical dispersion modeling, and inventory requirements which apply to reactive organic compounds. this compound is not considered to be a reactive organic compound. Under proposed amended Rule 202, Section D.10.1.2, use of more than 1 gallon per year per stationary source of this compound requires an Authority to Construct and Permit to Operate.

Santa Barbara County APCD

ІТЕМ	CHEMICAL OR PRODUCT (vapor pressure for select chemicals and products)	MOLECULAR FORMULA OR CHEMICAL FAMILY	ROC	ROC Content, grams per liter (lbs/gal)	SUBJECT TO 40CFR, PART 63, SUBPART T	CAS No.	ABBREVIATED OR POLLUTANT CODE	TACb	IBP ^c (°F)	HIGH OR LOW VOLATILITY SOLVENT ^d
22	1,1-dichloro-1-fluoroethane	C ₂ H ₃ Cl ₂ F	N	0 (0)	N	1717-00-6	HCFC- 141B	N	90	Н
23	3,3-dichloro-1,1,1,2,2- pentafluoropropane	C ₃ HCl ₂ F ₅	N ^f	0 (0)	N	422-56-0	HCFC- 225ca	N	Unavailable	Unavailable
24	1,3-dichloro-1,1,2,2,3- pentafluoropropane (HCFC- 225cb)	C ₃ HCl ₂ F ₅	N ^g	0 (0)	N	507-55-1	HCFC- 225cb	N	Unavailable	Unavailable
25	diethyl ether, ethyl ether	$C_4H_{10}O$	Y	713 (5.95)	N	60-29-7		N	94	Н
26	diethylene glycol	$C_4H_{10}O_3$	Y	1,117 (9.32)	N	111-46-6		Y	473	L (if not heated)
27	diethylene glycol dimethyl ether, diglyme	$C_6H_{14}O_3$	Y	944 (7.88)	N	111-96-6		Y	324	L (if not heated)
28	dimethoxyethane, glyme, ethylene glycol dimethyl ether, dimethyl cellosolve	$C_4H_{10}O_2$	Y	867 (7.24)	N	110-71-4	DME	Y	185	Н
29	dimethyl carbonate	$C_3H_6O_3$	N	0 (0.00)	N	616-38-6	DMC	N	194	Н
30	n,n-dimethyl-formamide, dimethyl formamide	C ₃ H ₇ NO	Y	943 (7.87)	N	68-12-2	DMF	Y	307	H or L ^h
31	dimethyl sulfoxide	C ₂ H ₆ OS	Y	1,091 (9.11)	N	67-68-5	DMSO	N	372	L (if not heated)
32	n,n-dimethylacetamide, dimethylacetamide	C ₄ H ₉ NO	Y	939 (7.84)	N	127-19-5	DMac, DMA	N	327	L (if not heated)
33	1,4 dioxane	$C_4H_8O_2$	Y	1,032 (8.62)	N	123-91-1		Y	214	Н
34	ethanol, ethyl alcohol	C ₂ H ₆ O	Y	788 (6.58)	N	64-17-5		N	173	Н
35	ethyl acetate	$C_4H_8O_2$	Y	893 (7.46)	N	141-78-6		N	171	Н
36	ethylene glycol	$C_2H_6O_2$	Y	789 (6.59)	N	107-21-1		Y	383	L (if not heated)
37	formic acid	CH ₂ O ₂	Y	1,209 (10.09)		64-18-6		N	212	Н

^g Consistent with 40CFR 51.100, this compound is not considered to be a reactive organic compound. However, under PAR 202, Section D.10.1, use of more than 1 gallon per year per stationary source of this compound requires an Authority to Construct and Permit to Operate.

^h The solvent may be a high or a low volatility solvent depending on the solvent's in-use temperature.

Santa Barbara County APCD

ITEM	CHEMICAL OR PRODUCT (vapor pressure for select chemicals and products)	MOLECULAR FORMULA OR CHEMICAL FAMILY	ROC	ROC Content, grams per liter (lbs/gal)	SUBJECT TO 40CFR, PART 63, SUBPART T	CAS No.	ABBREVIATED OR POLLUTANT CODE	TACb	IBP ^c (°F)	HIGH OR LOW VOLATILITY SOLVENT ^d
38	glycerin	$C_3H_8O_3$	Y	1,260 (10.52)	N	56-81-5		N	554	L (if not heated)
39	heptane	C_7H_{16}	Y	684 (5.70)	N	142-82-5		N	209	Н
40	hexane	C_6H_{14}	Y	660 (5.50)	N	110-54-3	HEX	Y	156	Н
41	isobutanol, isobutyl alcohol, 2-methylpropyl alcohol	$C_4H_{10}O$	Y	801 (6.69)	N	78-83-1		N	226	Н
42	isoparaffinic hydrocarbons, Isopar G	Hydroheated heavy naphtha (petroleum)	Y	749 (6.25)	N	64742-48-9		N	333	L (if not heated)
43	isopropyl alcohol, isopropanol, 2-propanol	C ₃ H ₈ O or C ₃ H ₇ OH	Y	785 (6.55)	N	67-63-0	IPA	Y	180	Н
44	isopropyl alcohol 70%	70% C ₃ H ₈ O or C ₃ H ₇ OH and 30% H ₂ O mixture	Y	549 (4.58)	N	67-63-0	IPA 70%	Y	180	Н
45	kerosene	Aliphatic petroleum hydrocarbons	Y	799 (6.67)	N	8008-20-6		N	347	L (if not heated)
46	d-limonene	$C_{10}H_{16}$	Y	839 (7.01)	N	5989-27-5		N	352	L (if not heated)
47	methanol, methyl alcohol	CH ₄ O	Y	799 (6.67)	N	67-56-1		Y	148	Н
48	1-methoxy-2-acetoxypropane; propylene glycol monomethyl ether acetate; PGMEA (3.7 mm of Hg @ 20° C)	C ₆ H ₁₂ O ₃	Y	969 (8.09)	N	108-65-6	PGMEA	Y	295	Н
49	2-methoxyethanol, ethylene glycol monomethyl ether, methyl cellosolve	C ₃ H ₈ O ₂	Y	964 (8.05)	N	109-86-4	EGME	Y	255	Н
50	methyl acetate	$C_3H_6O_2$	N	0 (0)	N	79-20-9		N	134	Н
51	methyl t-butyl ether, tert-butyl methyl ether	$C_5H_{12}O$	Y	741 (6.18)	N	1634-04-4	MTBE	Y	131	Н

ITEM	CHEMICAL OR PRODUCT (vapor pressure for select chemicals and products)	MOLECULAR FORMULA OR CHEMICAL FAMILY	ROC	ROC Content, grams per liter (lbs/gal)	SUBJECT TO 40CFR, PART 63, SUBPART T	CAS No.	ABBREVIATED OR POLLUTANT CODE	TACb	IBP ^c (°F)	HIGH OR LOW VOLATILITY SOLVENT ^d
52	methyl ethyl ketone, 2- butanone	C ₄ H ₈ O	Y	809 (6.76)	N	78-93-3	MEK	Y	176	Н
53	methyl formate; formic acid methyl ester, methyl methanoate (476 mm of Hg at 20° C)	HCOOCH₃	N ⁱ	0 (0)	N	107-31-3		N	90	Н
54	methyl isobutyl ketone	$C_6H_{12}O$	Y	799 (6.67)	N	108-10-1	MIBK	Y	243	Н
55	methyl nonafluoroisobutyl ether and methyl nonafluorobutyl ether (mix)	(CF ₃) ₂ CFCF ₂ OCH ₃ & C ₄ F ₉ OCH ₃	N ^j	0	0	163702-08- 7 & 163702-07- 6	HFE- 7100 (2 Isomers)	N	142	Н
56	n-methyl-2-pyrrolidone (NMP), n-methylpyrrolidone (<1 mm of Hg @ 20° C)	C₃H ₉ NO	Y	1,027 (8.57)	N	872-50-4	NMP	N	396	L (if not heated)
57	methylene chloride, dichloromethane	CH ₂ Cl ₂	N	0 (0)	Y	75-09-2	METH or DCM	Y	102	Н
58	mineral spirits 66/3 (< 1 mm of Hg @ 20° C)	C9-C13 Alkanes and Cycloalkanes	Y	779 (6.51)	N	64742-47-8		N	318	L (if not heated)
59	naphtha: solvent, medium aliphatic solvent naphtha (petroleum) (< 5 mm of Hg @ 20° C) ^k	Mixture of n- and iso- paraffins, aromatic hydrocarbons, and naphthenes	Y	784 (6.55)	N	64742-88-7		N	266	Н
60	nitromethane	CH ₃ NO ₂	Y	1,137 (9.49)	N	75-52-5		N	212	Н
61	parachlorobenzotrifluoride	C ₇ H ₄ ClF ₃	N	0 (0)	N	98-56-6	PCBTF	N	282	Н
62	pentane	C_5H_{12}	Y	626 (5.22)	N	109-66-0		N	97	Н
63	perchloroethylene, tetrachloroethylene	C_2Cl_4	N	0 (0)	Y	127-18-4	PERC or PERCH	Y	250	Н

Santa Barbara County APCD

ⁱ Consistent with 40CFR 51.100, this compound is not considered to be a reactive organic compound. However, under PAR 202, Section D.10.l, use of more than 1 gallon per year per stationary source of this compound requires an Authority to Construct and Permit to Operate.

^j Consistent with 40CFR 51.100, this compound is not considered to be a reactive organic compound. However, under PAR 202, Section D.10.1, use of more than 1 gallon per year per stationary source of this compound requires an Authority to Construct and Permit to Operate.

^k This solvent could be confused with VM&P Naphtha – CAS 8032-32-4.

ITEM	CHEMICAL OR PRODUCT (vapor pressure for select chemicals and products)	MOLECULAR FORMULA OR CHEMICAL FAMILY	ROC	ROC Content, grams per liter (lbs/gal)	SUBJECT TO 40CFR, PART 63, SUBPART T	CAS No.	ABBREVIATED OR POLLUTANT CODE	TACb	IBP ^c (°F)	HIGH OR LOW VOLATILITY SOLVENT ^d
64	1-propanol, n-propanol, m- propyl alcohol	C ₃ H ₈ O	Y	802 (6.70)	N	71-23-8		N	207	Н
65	n-propyl bromide; 1- bromopropane; 1-propyl bromide (112mm of Hg at 20° C)	C₃H₁Br	Y	1,352 (11.28)	N	106-94-5	nPB	N	160	Н
66	propylene carbonate	$C_4H_6O_3$	Y	1,204 (10.05)	N	108-32-7		N	464	L (if not heated)
67	pyridine	C ₅ H ₅ N	Y	981 (8.19)	N	110-86-1		N	239	Н
68	Safety Kleen 105 (0.4 mm of Hg at 20° C)	99 to 100 percent distillates (petroleum), hydrotreated light	Y	784 (6.55)	N	64742-47-8 (~99%) & 127-18-4		Un- known	310	H or L ¹
69	Stoddard solvent	>65% C10 or higher hydrocarbons	Y	789 (6.59)	N	8052-41-3		Un- known	313	H or L ¹
70	styrene, styrene monomer, vinyl benzene	C ₈ H ₈	Y	909 (7.60)	N	100-42-5		Y	293	H or L ¹
71	tetrahydrofuran	C ₄ H ₈ O	Y	885 (7.39)	N	109-99-9	THF	N	151	Н
72	toluene (21.86 mm of Hg @ 20° C)	C ₇ H ₈	Y	866 (7.23)	N	108-88-3		Y	231	Н
73	1,1,2-trichloro-1,2,2- trifluoroethane	CCl ₂ F-CClF ₂	N	0 (0)	N	76-13-1	CFC-113	Y	117	Н
74	1,1,1-trichloroethane; methyl chloroform	CH ₃ CCl ₃	N	0 (0)	Y	71-55-6	TCA	Y	165	Н
75	trichloroethylene; 1,1,2- trichloroethene; 1,2,2- trichloroethylene	C ₂ HCl ₃	Y	1,459 (12.18)	Y	79-01-6	TCE	Y	189	Н
76	trichlorofluoromethane	CCl ₃ F	N	0 (0)	N	75-69-4	CFC-11	Y	75	Н
77	turpentine	C ₁₀ H ₁₆ (approximate formula); turpentine has a minimum alphapinene content of 40 percent by weight	Y	859 (7.17)	N	8006-64-2		Un- known	302	H or L ¹

¹ The solvent may be a high or a low volatility solvent depending on the solvent's in-use temperature. Santa Barbara County APCD

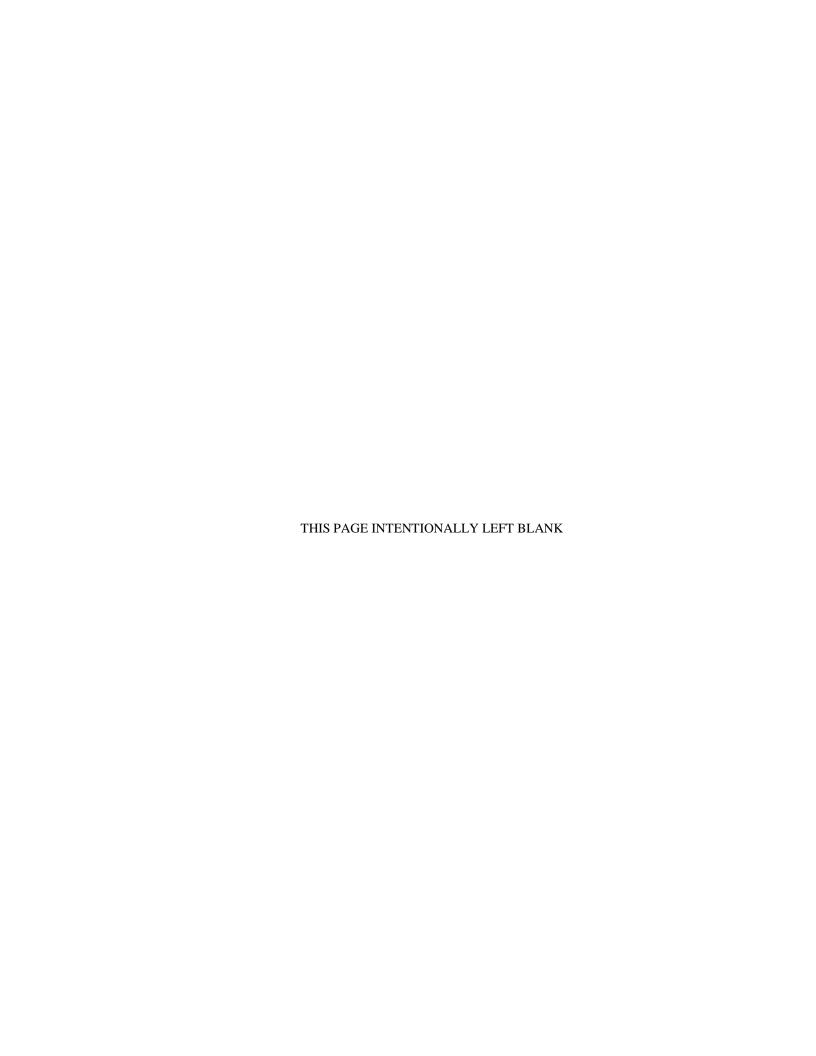
BACKGROUND PAPER - Rule 321 April 14, 2010

ITEM	CHEMICAL OR PRODUCT (vapor pressure for select chemicals and products)	MOLECULAR FORMULA OR CHEMICAL FAMILY	ROC	ROC Content, grams per liter (lbs/gal)	SUBJECT TO 40CFR, PART 63, SUBPART T	CAS No.	ABBREVIATED OR POLLUTANT CODE	TACb	IBP° (°F)	HIGH OR LOW VOLATILITY SOLVENT ^d
78	VM&P naphtha, petroleum ether, petroleum naphtha (14 mm of Hg @ 20° C) ^m	Aliphatic petroleum hydrocarbons (may also contain aliphatic petroleum distillate (CAS 64742-89-8))	Y	758 (6.32)	N	8032-32-4		Un- known	244	Н
79	X-Caliber $\{<65\%$ n-methyl-2-pyrrolidone [NMP] and $\geq 35\%$ d-limonene $\}$	Mixture of C_5H_9NO and $C_{10}H_{16}$	Y	919 (7.67)	N	872-50-4 and 5989- 27-5		N	370	L (if not heated)
80	<i>m</i> -xylene	C ₈ H ₁₀	Y	867 (7.24)	N	108-38-3		Y	282	H or L ⁿ
81	o-xylene	C_8H_{10}	Y	896 (7.48)	N	95-47-6		Y	291	H or L ^m
82	<i>p</i> -xylene	C ₈ H ₁₀	Y	860 (7.18)	N	106-42-3		Y	281	H or L ^m
83	xylenes	$C_8H_{10} (C_6H_4C_2H_6)$	Y	863 (7.21)	N	1330-20-7	XYLS	Y	281	H or L ^m

Click <u>here</u> to return to the list of Appendices in the Background Paper.

^m This solvent could be confused with naphtha: solvent - CAS 64742-88-7.

ⁿ The solvent may be a high or a low volatility solvent depending on the solvent's in-use temperature. Santa Barbara County APCD



Appendix O Santa Barbara County Proposed Amended Rules without Strikeout and Underlined Formatting

RULE 102. DEFINITIONS. (Adopted 10/18/1971, revised 1/12/1976, readopted 10/23/1978, revised 7/11/1989, 7/10/1990, 7/30/1991, 7/18/1996, 4/17/1997, 1/21/1999, 5/20/1999, 6/19/2003, 1/20/2005, 6/19/2008, and 1/15/2009), and [date of revised rule adoption])

These definitions apply to the entire rulebook. Definitions specific to a given rule are defined in that rule or in the first rule of the relevant regulation. Except as otherwise specifically provided in these Rules where the context otherwise indicates, words used in these Rules are used in exactly the same sense as the same words are used in Division 26 of the Health and Safety Code.

 $[\ldots]$

"Application Equipment" means a device or equipment used to apply solvent, sealant, adhesive, coating, ink, or polyester resin materials.

[...]

"Coating" means a material applied onto or impregnated into a substrate for protective, decorative, or functional purposes. Such materials include, but are not limited to, paints, varnishes, sealers, and stains.

 $[\ldots]$

"Cured Adhesive, Cured Coating, or Cured Ink" means an adhesive, coating, or ink that is dry to the touch.
[...]

"Degreaser" has the same meaning as "Solvent Cleaning Machine."

[...]

"Flexographic Printing" means any printing method in which the image area is raised relative to the non-image area and utilizes flexible rubber or other elastomeric plate and rapid drying liquid inks.

 $[\ldots]$

- "Janitorial Cleaning" means the cleaning of building or facility components including, but not limited to, floors, ceilings, walls, windows, doors, stairs, bathrooms, furnishings, and exterior surfaces of office equipment; excluding the cleaning of work areas associated with:
 - 1. research and development, manufacturing, and repair activities; and
 - 2. laboratory tests and analyses (including quality assurance and quality control activities) and bench scale projects.

 $[\ldots]$

"Organic Solvents" means organic materials, including diluents and thinners which are liquid at standard conditions and which are used as, dissolvers, viscosity reducers or cleaning agents, except that such materials which exhibit a boiling point, as measured using ASTM D 1078-05, "Standard Test Method for Distillation Range of Volatile Organic Liquids," ASTM International, higher than 220°F at 0.5 millimeter mercury absolute pressure or having an equivalent vapor pressure shall not be considered to be organic solvents unless exposed to temperatures exceeding 220°F.

- "Photochemically Reactive Solvent" means any organic solvent with an aggregate of more than 20 percent of its total volume composed of the chemical compounds classified below or which exceeds any of the following individual percentage composition limitations, referred to the total volume of organic solvent;
 - 1. combination of hydrocarbons, alcohols, aldehydes, esters, ethers or ketones, having an olefinic or cyclolefinic type of unsaturation: 5 percent, or
 - 2. combination of aromatic compounds with 8 or more carbon atoms to the molecule, except ethylbenzene: 8 percent, or
 - 3. combination of ethylbenzene, ketones having branched hydrocarbon structures, trichloroethylene or toluene: 20 percent.

Whenever any organic solvent or any constituent of an organic solvent may be classified from its chemical structure into more than one of the above groups of organic compounds, it shall be considered as a member of the most reactive chemical group, i.e., that group having the least allowable percent of the total volume of organic solvents.

$[\ldots]$

"Reactive Organic Compound" means any compound containing at least one (1) atom of carbon, except for the following exempt compounds:

- 1. acetone
- 2. ammonium carbonate
- 3. carbon dioxide
- 4. carbon monoxide
- 5. carbonic acid
- 6. dimethyl carbonate
- 7. ethane
- 8. metallic carbides or carbonates
- 9. methane
- 10. methyl acetate
- 12. methyl chloroform (1,1,1-trichloroethane)
- 12. methyl formate; HCOOCH₃
- 13. cyclic, branched, or linear completely methylated siloxane compounds

Methylated siloxane compounds shall be assumed to be absent from a product or process unless a manufacturer or facility operator identifies the specific individual compounds (from broad classes of these compounds) and the amounts present in the product or process, and provides an Environmental Protection Agency approved test method which can be used to quantify the specific compounds.

- 14. methylene chloride
- 15. Parachlorobenzotrifluoride
- 16. perchloroethylene (tetrachloroethylene)
- 17. the following four classes of perfluorocarbon (PFC) compounds:
 - a. cyclic, branched, or linear, completely fluorinated alkanes,
 - b. cyclic, branched, or linear, completely fluorinated ethers with no unsaturations,
 - c. cyclic, branched, or linear, completely fluorinated tertiary amines with no unsaturations, and
 - sulfur containing perfluorocarbons with no unsaturations and with sulfur bonds only to carbon and fluorine.

Perfluorocarbon compounds shall be assumed to be absent from a product or process unless a manufacturer or facility operator identifies the specific individual compounds (from broad classes of these compounds) and the amounts present in the product or process, and provides an Environmental Protection Agency approved test method which can be used to quantify the specific compounds.

- 18. propylene carbonate
- 19. tertiary-butyl acetate; C₆H₁₂O₂ (1,1-dimethylethyl ester)

Tertiary-butyl acetate (also known as t-butyl acetate or tBAc) shall be considered exempt as a reactive organic compound only for purposes of reactive organic compound emissions limitations or reactive organic compound content requirements and will continue to be a reactive organic compound for purposes of all recordkeeping, emissions reporting, photochemical dispersion modeling, and inventory requirements which apply to reactive organic compounds.

- 20. CFC-11 (trichlorofluoromethane)
- 21. CFC-12 (dichlorodifluoromethane)
- 22. CFC-113 (1,1,2-trichloro-1,2,2-trifluoroethane)
- 23. CFC-114 (1,2-dichloro 1,1,2,2-tetrafluoroethane)
- 24. CFC-115 (chloropentafluoroethane)
- 25. HCFC-22 (chlorodifluoromethane)
- 26. HCFC-31 (chlorofluoromethane)
- 27. HCFC-123 (1,1,1-trifluoro 2,2-dichloroethane)
- 28. HCFC-123a (1,2-dichloro-1,1,2-trifluoroethane)
- 29. HCFC-124 (2-chloro-1,1,1,2-tetrafluoroethane)
- 30. HCFC-141b (1,1-dichloro 1-fluoroethane)
- 31. HCFC-142b (1-chloro-1,1 difluoroethane)
- 32. HCFC-151a (1-chloro-1-fluoroethane)
- 33. HCFC-225ca (3,3-dichloro-1,1,1,2,2-pentafluoropropane)
- 34. HCFC-225cb (1,3-dichloro-1,1,2,2,3-pentafluoropropane)
- 35. HFC-23 (trifluoromethane)
- 36. HFC-32 (difluoromethane)
- 37. HFC-43-10mee (1,1,1,2,3,4,4,5,5,5-decafluoropentane)
- 38. HFC-125 (pentafluoroethane)
- 39. HFC-134 (1,1,2,2-tetrafluoroethane)
- 40. HFC-134a (1,1,1,2-tetrafluoroethane)
- 41. HFC-143a (1,1,1-trifluoroethane)
- 42. HFC-152a (1,1-difluoroethane)
- 43. HFC-161 (ethylfluoride)
- 44. HFC-236ea (1,1,1,2,3,3-hexafluoropropane)
- 45. HFC-236fa (1,1,1,3,3,3-hexafluoropropane)
- 46. HFC-245ca (1,1,2,2,3-pentafluoropropane)
- 47. HFC-245ea (1,1,2,3,3-pentafluoropropane)
- 48. HFC-245eb (1,1,1,2,3-pentafluoropropane)
- 49. HFC-245fa (1,1,1,3,3-pentafluoropropane)
- 50. HFC-365mfc (1,1,1,3,3-pentafluorobutane)
- 51. HFE-7100; $(CF_3)_2CFCF_2OCH_3$; (2-(difluoromethoxymethyl)-1,1,1,2,3,3,3-heptafluoropropane) or $C_4F_9OCH_3$; (1,1,1,2,2,3,3,4,4-nonafluoro-4-methoxy-butane)
- 52. HFE-7200; $(CF_3)_2CFCF_2OC_2H_5$; (2-(ethoxydifluoromethyl)-1,1,1,2,3,3,3-heptafluoropropane) or $C_4F_9OC_2H_5$; (1-ethoxy-1,1,2,2,3,3,4,4,4-nonafluorobutane)

Rule 202.D.10.1.1 requires an Authority to Construct and Permit to Operate when using more than one gallon per year per stationary source of any one of the following exempt compounds: dimethyl carbonate, methyl formate, HCFC-225ca, HCFC-225cb, HFC-43-10mee, HFC-245fa, HFC-365mfc, or HFE-7100 [(CF₃)₂CFCF₂OCH₃ or $C_4F_9OC_2H_5$]. Rule 202.D.10.1.2 requires an Authority to Construct and Permit to Operate when using more than one gallon per year per stationary source of tertiary-butyl acetate. The one gallon per year per stationary source limit is a per compound limit for each compound in aggregate for the entire stationary source and includes any amounts of the compound used in mixed or diluted product.

 $[\ldots]$

"Rotogravure Printing" means any printing process where the image area is etched or engraved relative to the surface of the image cylinder. Ink is transferred from minute etched wells on a plate cylinder to a substrate, which is supported by an impression roller, with excess ink removed by a doctor blade. The substrate is fed through the printing press in continuous rolls.

[...]

"Solvent" means any liquid containing any reactive organic compound or any toxic air contaminant, which is used as a diluent, thinner, dissolver, viscosity reducer, cleaning agent, drying agent, preservative, or other similar uses.

"Solvent Cleaning" means any activity, operation, or process (including, but not limited to, surface preparation, cleanup, or wipe cleaning) performed outside of a solvent cleaning machine, that uses solvent to remove uncured adhesives, uncured coatings, uncured inks, uncured polyester resin material, uncured sealant, or other contaminants, including, but not limited to, dirt, soil, oil, lubricants, coolants, moisture, fingerprints, and grease, from parts, products, tools, machinery, application equipment, and general work areas. Cleaning spray equipment used for the application of coating, adhesive, ink, polyester resin material, or sealant is also considered to be solvent cleaning irrespective of the spray material being cured.

"Solvent Cleaning Machine" means any device or piece of equipment that uses solvent liquid or vapor to remove soils, moisture, or other contaminants from the surfaces of materials. Types of solvent cleaning machines include, but are not limited to, batch cold, batch vapor, in-line cold, in-line vapor, remote reservoir, and gas-path solvent cleaners, as defined in Rule 321. Buckets, pails, and beakers with capacities of 3.785 liters (1.00 gallon) or less are not considered solvent cleaning machines. However, the use of such a container or similar containers (e.g., hand-held spray bottles) with a solvent for cleaning is considered to be solvent cleaning. Any device or piece of equipment used exclusively for stripping shall not be considered to be a solvent cleaning machine.

[...]

"Stripping" means the use of solvent to remove materials such as cured adhesives, cured inks, cured sealants, cured or dried paints, cured or dried paint residues, or temporary protective coatings.

"Surface Preparation" means the removal of contaminants such as dust, soil, oil, grease, moisture, etc., prior to application of an adhesive, coating, ink, polyester resin material, or sealant.

 $[\ldots]$

"Toxic Air Contaminant" means "Toxic air contaminant' as defined in Health and Safety Code Section 39655.

[...]

"Wipe Cleaning" means a solvent cleaning activity performed by hand rubbing an absorbent material such as a rag, paper, sponge, brush, or cotton swab containing solvent.

RULE 202. EXEMPTIONS TO RULE 201. (Adopted 10/18/1971, revised 5/1/1972 and 6/27/1977, readopted 10/23/1978, revised 12/7/1987, 1/11/1988, 1/17/1989, 7/10/1990, 7/30/1991, 11/05/1991, 3/10/1992, 5/10/1994, 6/28/1994, 4/17/1997, 3/17/2005, 1/17/2008, 6/19/2008, and [date of revised rule adoption])

[...]

- **D.** General Provisions [...]
 - 5. Temporary Equipment
 - [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees.

 $[\ldots]$

- 7. Stationary Source Permit Exemption
 - [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees.

 $[\ldots]$

10. Notwithstanding any exemption defined in this rule, no new or modified stationary source that has the potential to emit air contaminants in excess of the amounts specified shall be exempt from permit requirements:

- k. 40 tons per year municipal waste combustor acid gases.
- 1. In addition, notwithstanding any exemption defined in this rule, no stationary source that has the potential to emit any air contaminants in excess of the amounts specified shall be exempt from permit requirements:
 - more than one gallon per year of any one of the exempt compounds listed below. The one gallon per year per stationary source limit is a per compound limit for each compound in aggregate for the entire stationary source and includes any amounts of the compound used in mixed or diluted product.
 - a) dimethyl carbonate; or
 - b) methyl formate; HCOOCH₃; or
 - c) HCFC-225ca (3,3-dichloro-1,1,1,2,2-pentafluoropropane); or
 - d) HCFC-225cb (1,3-dichloro-1,1,2,2,3-pentafluoropropane); or
 - e) HFC-43-10mee (1,1,1,2,3,4,4,5,5,5-decafluoropentane); or
 - f) HFC-245fa (1,1,1,3,3-pentafluoropropane); or
 - g) HFC-365mfc (1,1,1,3,3-pentafluorobutane); or
 - h) HFE-7100; (CF₃)₂CFCF₂OCH₃; (2-(difluoromethoxymethyl)-1,1,2,3,3,3-heptafluoropropane); or
 - i) HFE-7100; $C_4F_9OCH_3$; (1,1,1,2,2,3,3,4,4-nonafluoro-4-methoxybutane); or

2. more than one gallon per year of tertiary-butyl acetate; $C_6H_{12}O_2$ (1,1-dimethylethyl ester). Tertiary-butyl acetate (also known as t-butyl acetate or tBAc) shall be considered exempt as a reactive organic compound only for purposes of reactive organic compound emissions limitations or reactive organic compound content requirements and will continue to be a reactive organic compound for purposes of all recordkeeping, emissions reporting, photochemical dispersion modeling, and inventory requirements which apply to reactive organic compounds. The one gallon per year per stationary source limit for tertiary-butyl acetate is an aggregate limit for the entire stationary source and includes any amounts of the compound used in mixed or diluted product.

 $[\ldots]$

E. Compliance with Rule Changes

 $[\ldots]$

If no application is filed within the ninety (90) day period, the application filing fee prescribed in Rule 210, Fees, shall be doubled and the equipment owner shall be subject to a Notice of Violation and to the penalty provisions set forth in California Health and Safety Code Sections 42400 et seq.

[...]

F. Internal Combustion Engines

 $[\ldots]$

5. [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees. [...]

 $[\ldots]$

- 7. [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees. [...]
- 8. [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees. [...]

[...]

I. Coatings Applications Equipment and Operations

The following listed coating applications equipment and operations are exempt from permit requirements. $[\ldots]$

- 3. Equipment used in surface coating operations provided that the total amount of coatings and solvents used does not exceed 55 gallons per year. [...] Solvents meeting the criteria of Section U.2.b or Section U.2.c or that have a reactive organic compound content of 50 grams per liter or less, as determined by the Environmental Protection Agency Reference Method 24, do not contribute to the 55 gallons per year per stationary source limitation. [...]
- 6. Unheated non-conveyorized coating dip tanks of 100 gallons or less capacity.

 $[\ldots]$

K. Food Processing and Preparation Equipment

[...]

7. [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees.

P. Miscellaneous Equipment and Operations

[...]

14. [...] The owner or operator shall pay any applicable fee pursuant to Rule 210, Fees. [...]

[...]

U. Solvent Application Equipment and Operations

The following solvent cleaning, solvent cleaning machines and their operations are exempt from permit requirements. Notwithstanding the listed exemptions, any collection of articles, machines, equipment or other contrivances within each listed equipment category at a stationary source that has aggregate emissions in excess of 10 tons per calendar year of any affected pollutant is not exempt.

- 1. Unheated nonconveyorized solvent rinsing containers of 1.00 gallon or less capacity provided that solvent cleaning performed in association with such containers complies with the requirements in Rule 321, Solvent Cleaning Machines and Solvent Cleaning.
- 2. Single solvent cleaning machines, which use unheated solvent, and which:
 - have a liquid surface area (i.e., the area of the drain for remote reservoir cleaning machines or the solvent/air interface area for other solvent cleaning machines) of less than 929 square centimeters (1.0 square foot), unless the aggregate liquid surface area of all solvent cleaning machines at a stationary source, covered by this exemption is greater than 0.929 square meter (10 square feet), or
 - b. use only solvents with an initial boiling point of 150 degrees Celsius (302 degrees Fahrenheit) or greater as determined by ASTM D-1078-05, Standard Test Method for Distillation Range of Volatile Organic Liquids, ASTM International, or
 - c. use solvents with a reactive organic compound content of two percent or less by weight as determined by Environmental Protection Agency Method 24.
 - d. The liquid surface area of any solvent cleaning machine using the following solvent shall not be counted towards the 0.929 square meter (10 square feet) aggregate limit in subsection a. above:
 - i. any solvent that has a reactive organic compound content of 50 grams per liter or less, as determined by the Environmental Protection Agency Method 24, or
 - ii. any solvent exempt pursuant to subsection b. or subsection c. above.
- 3. Wipe cleaning operations, provided that the solvents used do not exceed 55 gallons per year per stationary source and that the solvent cleaning complies with the requirements in Rule 321, Solvent Cleaning Machines and Solvent Cleaning.

To qualify for this exemption, the owner or operator shall maintain records of the amount (gallons per year) of solvents used for wipe cleaning at the stationary source for each calendar year.

These records shall be maintained on site for at least 3 years and be made available to the District on request. Thereafter, the records shall be maintained either on site or readily available for expeditious inspection and review for an additional 2 years. Solvents meeting the criteria of 2.b. or c. above or that have a reactive organic compound content of 50 grams per liter or less, as determined by the Environmental Protection Agency Reference Method 24, do not contribute to the 55 gallons per year per stationary source limitation.

- 4. Notwithstanding the Section U.3 exemption above, solvent cleaning to disinfect and decontaminate surfaces and equipment in hospitals, clinics, medical facilities, dentistry facilities, and other health care facilities, including but not limited to, sanatoriums, convalescent hospitals, convalescent homes, skilled nursing facilities, nursing homes, blood banks, and bloodmobiles.
- 5. Notwithstanding the Section U.3 exemption above, solvent cleaning associated with janitorial cleaning, including graffiti removal.

[...]

RULE 321. SOLVENT CLEANING MACHINES AND SOLVENT CLEANING. (Adopted 2/24/1975, readopted 10/23/1978, revised 6/11/1979, 7/10/1990, 4/17/1997, 7/17/1997, 9/18/1997, and [date of revised rule adoption])

A. Applicability

This rule shall apply to any person who owns, operates, or uses any solvent cleaning machine or performs any solvent cleaning operation outside of a solvent cleaning machine during the production, repair, maintenance, or servicing of parts, products, tools, machinery, equipment, or in general work areas at any stationary source.

B. Exemptions

Except as otherwise specifically provided herein, the provisions of this rule shall not apply to the following:

- 1. Any solvent cleaning machine equipped with and any solvent cleaning performed with a solvent (including emulsions) that contains two percent by weight or less of each of the following:
 - a. Reactive organic compounds (as determined by Environmental Protection Agency method 24), and
 - b. Toxic air contaminants (as determined by generic solvent data, solvent manufacturer's composition data or by a gas chromatography test and a mass spectrometry test).
 - c. Any person claiming this exemption shall maintain the records specified in Sections R.1.a.1) and R.1.a.2) in a manner consistent with Section R.3 and make them available for review.
- 2. The cleaning of architectural coating application equipment provided that the solvent used does not exceed 950 grams of reactive organic compound per liter of material.
- 3. Dry cleaning operations of clothing or other fabrics covered under Rule 320, Petroleum Solvent Dry Cleaners, or California Code of Regulations Title 17, Section 93109, Airborne Toxic Control Measure for Emissions of Perchloroethylene from Dry Cleaning and Water-Repelling Operations.
- 4. Stripping of cured coatings, cured adhesives, cured sealants, and cured inks, except the stripping of such materials from spray application equipment.
- 5. Notwithstanding Section B.1, any solvent cleaning machine that uses any halogenated hazardous air pollutant solvent provided such a solvent cleaning machine is subject to 40 CFR, Part 63, Subpart T, National Emission Standards for Halogenated Solvent Cleaning (Sections 63.460 et. seq.).
- 6. Any equipment or operation that is subject to or specifically exempted by any of the following District rules.
 - a. Rule 325, Crude Oil Production and Separation.
 - b. Rule 326, Storage of Reactive Organic Compound Liquids.
 - c. Rule 330, Surface Coating of Metal Parts and Products.
 - d. Rule 337, Surface Coating of Aircraft or Aerospace Vehicle Parts and Products.
 - e. Rule 339, Motor Vehicle and Mobile Equipment Coating Operations.
 - f. Rule 343, Petroleum Storage Tank Degassing.

- g. Rule 344, Petroleum Sumps, Pits and Well Cellars.
- h. Rule 349, Polyester Resin Operations.
- i. Rule 351, Surface Coating of Wood Products.
- j. Rule 353, Adhesives and Sealants.
- k. Rule 354, Graphic Arts.
- 7. Janitorial cleaning, including graffiti removal.
- 8. Provisions of Sections H.7, I.7, K.6, and, M.1 shall not apply to the following:
 - Cleaning of solar cells, laser hardware, scientific instruments, high-precision optics, telescopes, microscopes, avionic equipment, and aerospace and military fluid systems; and
 - b. Cleaning in laboratory tests and analyses, including quality assurance and quality control applications, bench scale projects, or short-term (less than 2 years) research and development projects; and
 - c. Cleaning of cotton swabs to remove cottonseed oil before cleaning of high-precision optics.
 - d. In addition, the provisions of Sections H.7, I.7, and K.6 shall not apply to solvent cleaning machines employed with solvents having 900 grams of reactive organic compound per liter of material or less during the production, repair, maintenance, or servicing of electrical apparatus components, electronic components, satellites components, aerospace vehicles, aerospace vehicle components, aerospace vehicle payloads, aerospace vehicle payload components, medical devices, or silicone manufacturing.
- 9. Solvent cleaning with aerosol products shall not be subject to Section D.9 and Section M.1 provisions and the Section M.2.c prohibition on solvent atomization provided:
 - a. 160 fluid ounces or less of aerosol products are used per day, per facility, and
 - b. Records are maintained as specified in Sections R.2 and R.3, and
 - c. The aerosol products comply with volatile organic compound limits for consumer products specified in the California Code of Regulations, Title 17, Section 94507 et seq.
- 10. Provisions of Section M.1, Table 1, Solvent Cleaning Activity (c) shall not apply to the cleaning of application equipment when such equipment is used to apply a coating on a satellite or when applying a radiation-effect coating.
- 11. Section D.9 and M.2.c prohibitions on solvent atomization shall not apply to the following applications:
 - a. Cleaning of the nozzle tips of automated spray equipment systems, except for robotic systems.
 - b. Cleaning with hand-held spray bottles, squirt bottles, and other closed containers having a capacity of one liter or less.
 - c. Cleaning of gas turbines or jet engines using a gas-path solvent cleaner.

- 12. De-icing of aircraft and aerospace vehicles.
- 13. Solvent cleaning with a solvent containing 50 grams of reactive organic compounds per liter of material or less shall not be subject to the Section D.9 provision.
- 14. Solvent cleaning to disinfect and decontaminate surfaces and equipment in hospitals, clinics, medical facilities, dental care facilities, and other health care facilities, including but not limited to, sanatoriums, convalescent hospitals, convalescent homes, skilled nursing facilities, nursing homes, blood banks, and bloodmobiles.
- 15. Provisions of Section M.1 shall not apply if the net aggregate amount of solvent used for all solvent cleaning subject to Rule 321 (i.e., subject to Sections D, M.2, and/or M.3 provisions) at a stationary source does not exceed 55 gallons per year. Solvents with a reactive organic compound content of 50 grams per liter of material or less do not count towards the 55 gallons per year aggregate limit. Any person claiming this exemption shall maintain records as specified in Sections R.2 and R.3.
- 16. Provisions of Section M.1 shall not apply to the following applications:
 - a. Cleaning of ultraviolet lamps used to cure ultraviolet inks coatings, adhesives, or resins.
 - b. Cleaning of mold release compounds from molds.
 - c. Cleaning of aerospace assembly and subassembly surfaces that are exposed to strong oxidizers or reducers such as nitrogen tetroxide, liquid oxygen, or hydrazine.
 - d. Cleaning of paper gaskets.
 - e. Cleaning of clutch assemblies where rubber is bonded to metal by means of an adhesive.
 - f. Cleaning of hydraulic actuating fluid from filters and filter housings.
 - g. Wipe cleaning to remove crude oil and crude oil residue from well workover, drilling operations, and other activities related to petroleum production and processing on offshore platforms, provided the solvent reactive organic compound content does not exceed 800 grams per liter of material and the reactive organic compound composite partial pressure is no more than 8 millimeters of mercury at 20 degrees Celsius.
- 17. Provisions of Sections H.7, I.7, and K.6 shall not apply to the following applications, provided the solvent reactive organic compound content does not exceed 900 grams per liter of material and the reactive organic compound composite partial pressure is no more than 5 millimeters of mercury at 20 degrees Celsius:
 - a. Cleaning associated with the manufacturing of nuts and bolts designed for automotive racing applications.
 - b. Cleaning of precision-lapped mechanical seals in pumps that handle liquefied gasses.
- 18. Provisions of Sections J.11.a, d, and e shall not apply to batch vapor cleaning machines with a solvent/air interface area less than 929 square centimeters (1 square foot) or a solvent capacity less than 2 gallons, provided all such solvent cleaning machines emit, in aggregate, less than 55 pounds of reactive organic compounds per month per stationary source. Any person claiming this exemption shall maintain records as specified in Sections R.1 and R.3.
- 19. The use of solvent for purposes other than cleaning.
- 20. The Section E.7 and Section J.11.a, d, and e provisions shall not apply to batch vapor cleaning machines provided:

- a. The equipment was installed before January 1, 2007; and
- b. The solvent/air interface area is less than 4.40 square feet or the solvent capacity is less than 2 gallons; and
- c. The equipment is used only for cleaning electronic components; and
- d. The total aggregate reactive organic compound emissions from all batch vapor cleaning machines subject to this exemption do not exceed 188 pounds per month per stationary source; and
- e. The equipment is subject to a Permit to Operate to help facilitate verifications that the requirements of subparagraphs B.20.a, b, c, and d are met.
- f. In addition, the Section J.8 requirement to have a freeboard ratio of 1.0 or greater shall not apply to solvent cleaning machines meeting the requirements in subsections a—e above, provided the solvent cleaning machines have a freeboard ratio of 0.75 or greater.
- 21. The Section I.3, I.4, and I.7 requirements for unheated batch cleaning machines shall not apply, provided the equipment is used in medical device manufacturing when performing incidental product cleaning in conjunction with quality assurance or quality control tests (e.g., when conducting leak testing of silicone shells) and the solvent reactive organic compound content does not exceed 900 grams per liter of material.
- 22. Metal lift-off and other semiconductor and microelectromechanical device manufacturing processes involving thin film deposition, vacuum deposition, and dry etching operations; including any maintenance activities associated with such operations.
- 23. The solvent container draining and filling provisions in Section D.12 shall not apply to solvent transfers out of a sump, provided the sump has a maximum capacity of 8 gallons or less, such sump is easily removed from the solvent cleaning machine, and the solvent is poured from the sump directly into a bulk storage container.
- 24. Any batch vapor cleaning machine meeting all of the following requirements shall be exempt from the Section J.8 requirement to have a freeboard ratio of 1.0:
 - a. The equipment is used only for cleaning electronic components; and
 - b. The dimensions are such that the freeboard ratio is 0.75 or greater; and
 - c. The solvent cleaning machine is equipped with the freeboard refrigeration device for which the chilled air blanket temperature (expressed in degrees Fahrenheit) at the coldest point on the vertical axis in the center of the air blanket shall be no greater than 30 percent of the initial boiling point (expressed in degrees Fahrenheit) of the solvent used or no greater than minus 4 degrees Fahrenheit; and
 - d. The batch vapor cleaning machine is equipped with a superheated vapor zone where parts remain in the vapor zone for at least the minimum dwell time, as specified by the manufacturer. The temperature within the superheated vapor zone shall be at least 10 degrees Fahrenheit above the initial boiling point of the solvent being used.

C. Definitions

See Rule 102 for definitions not limited to this rule. For purposes of this rule the following definitions shall apply:

- "Aerosol Product" means a hand-held, non-refillable container that expels pressurized product by means of a propellant-induced force.
- "Aerospace Vehicle" means the completed unit of any aircraft, helicopter, missile, or space vehicle.
- "Aerospace Vehicle Component" means any raw material, partial or completed fabricated part, assembly of parts, or completed unit of any aircraft, helicopter, missile, or space vehicle, including mockups and prototypes.
- "Air Blanket" means the layer of air inside the solvent cleaning machine freeboard located above the solvent/air interface.
- "Airless Solvent Cleaning Machine" means any solvent cleaning machine that is automatically operated and seals at an absolute internal pressure of 0.02 pounds per square inch absolute or less, prior to the introduction of solvent vapor into the cleaning chamber and maintains differential pressure under vacuum during all cleaning and drying cycles.
- "Air-Tight Solvent Cleaning Machine" means any solvent cleaning machine that is automatically operated and seals at a differential pressure no greater than 0.5 pounds per square inch absolute during all cleaning and drying operations.
- "Automated Parts Handling System" means a mechanical device that carries all parts and parts baskets at a controlled speed from the initial loading of soiled or wet parts through the removal of the cleaned or dried parts. Automated parts handling systems include, but are not limited to, hoists and conveyors.
- "Batch Cleaning Machine" means a solvent cleaning machine in which individual parts or a set of parts move through the entire cleaning cycle before new parts are introduced into the solvent cleaning machine. An open-top vapor cleaning machine is a type of batch cleaning machine. A solvent cleaning machine, such as a Ferris wheel or a cross-rod degreaser, that clean multiple batch loads simultaneously and are manually or semi-continuously loaded are batch cleaning machines.
- "Bench Scale Project" means a project (other than at a research and development facility) that is operated on a small scale, such as one capable of being located on a laboratory bench top.
- "Carbon adsorber" means a bed of activated carbon into which an air-solvent gas-vapor stream is routed and which adsorbs the solvent on the carbon.
- "Carry-out" see "Drag-out."
- "Circumferential Trough" means a receptacle located below the primary condenser that conveys condensed solvent and atmospheric moisture to a water separator.
- "Cold Cleaning Machine" means any device or piece of equipment that contains and/or uses liquid solvent, into which parts are placed to remove soils from the surfaces of the parts or to dry the parts. Cleaning machines that contain and use heated, nonboiling solvent to clean the parts are classified as cold cleaning machines. Cold solvent wash stations are classified as cold cleaning machines.
- "Condenser" or "Primary Condenser" means a series of circumferential cooling coils on a vapor cleaning machine through which a chilled substance is circulated or recirculated to provide continuous condensation of rising solvent vapors and, thereby, create a concentrated solvent vapor zone.
- "Condenser Flow Switch" means a safety switch connected to a thermostat that shuts off the sump heater if the condenser coolant is either not circulating or exceeds its designed operating temperature.
- "Continuous Cleaning Machine" see "In-Line Cleaning Machine."
- "Continuous Web Cleaning Machine" means a solvent cleaning machine in which parts such as film, coils, wire, and metal strips are cleaned at speeds typically in excess of 11 feet per minute. Parts are

- generally uncoiled, cleaned such that the same part is simultaneously entering and exiting the solvent application area of the solvent cleaning machine, and then recoiled or cut. For the purposes of this rule, all continuous web cleaning machines are considered to be a subset of in-line solvent cleaning machines.
- "Conveyorized (In-Line or Continuous) Cold Cleaning Machine" means any continuously loaded solvent cleaning machine that is not a conveyorized vapor cleaning machine.
- "Conveyorized (In-Line or Continuous) Cleaning Machine" means any cold or vapor solvent cleaning machine, that uses an automated parts handling system to automatically provide a continuous supply of parts to be cleaned. Conveyorized (in-line or continuous) cleaning machines include but are not limited to vibra, monorail, mesh, belt, web, and strip cleaning machines. Strip cleaning machines clean material by drawing the strip itself through the unit for cleaning prior to coating or other fabrication processes. For the purposes of this rule "Conveyorized (In-Line or Continuous) Cleaning Machine" has the same meaning as "In-Line Cleaning Machine."
- "Conveyorized (In-Line or Continuous) Vapor Cleaning Machine" means any continuously loaded solvent cleaning machine that immerses parts in boiling solvent or in solvent vapors generated by boiling solvent. Conveyorized (in-line or continuous) cleaning machines that contain any vapor cleaning sections shall be considered to be conveyorized vapor cleaning machines for the purposes of this rule.
- "Cross-Rod Solvent Cleaning Machine" means a batch solvent cleaning machine in which parts baskets are suspended from "cross-rods" as they are moved through the machine. In a cross-rod cleaning machine, parts are loaded semi-continuously, and enter and exit the machine from a single portal.
- "Downtime Mode" means the time period when a solvent cleaning machine is not cleaning parts and the sump heating coils, if present, are turned off.
- "Drag-out" means solvent carried out of a solvent cleaning machine that adheres to or is entrapped in the part being removed.
- "Drying Tunnel" means an add-on enclosure extending from the exit area of a solvent cleaning machine that reduces drag-out losses by containing evaporating solvent.
- **"Dwell"** means the technique of holding parts within the freeboard area but above the vapor zone of the solvent cleaning machine. Dwell occurs after cleaning to allow solvent to drain from the parts or parts baskets back into the solvent cleaning machine.
- **"Dwell Time"** means the period of time when parts are held within the freeboard area of the solvent cleaning machine, after cleaning, to allow solvent to drain from the parts back into the solvent cleaning machine.
- "Electrical Apparatus Components" means the internal components such as wires, windings, stators, rotors, magnets, contacts, relays, energizers, and connections in an apparatus that generates or transmits electrical energy including, but not limited to: alternators, generators, transformers, electric motors, cables, and circuit breakers, except for the actual cabinet in which the components are housed. Electrical components of graphic arts application equipment and hot-line tools are also included in this category.
- "Electronic Components" means the portions of an assembly, including, but not limited to: circuit card assemblies, printed wire assemblies, printed circuit boards, soldered joints, ground wires, bus bars, magnetic tapes and tape drive mechanisms, discs and disc drive mechanisms, electro-optical devices (e.g., optical filters, sensor assemblies, infrared sensors, charged coupled devices, thermal electric coolers, and vacuum assemblies), solid state components, semiconductors (e.g., diodes, zeners, stacks, rectifiers, integrated microcircuits, transistors, solar cells, light sensing devices, and light-emitting devices), and other electrical fixtures, except for the actual cabinet in which the components are housed.
- "Emulsion" means a suspension of small droplets of one liquid in a second liquid.

- **"Emission Control Device"** means a device for reducing emissions of reactive organic compounds or toxic air contaminants to the atmosphere.
- "Evaporation" means to change into a vapor, normally from a liquid state.
- **"Existing Solvent Cleaning Operation"** means solvent cleaning that is being performed as of [date of revised rule adoption].
- "Existing Solvent Cleaning Machine" means any solvent cleaning machine that is installed as of [date of revised rule adoption]
- **"Fluid System"** means a power transmission system that uses the force of flowing liquids and gases to transmit power. Fluid systems include hydraulic systems and pneumatic systems.
- "Freeboard Area" means; for a batch cleaning machine, the area within the solvent cleaning machine that extends from the solvent/air interface to the top of the solvent cleaning machine; for an in-line cleaning machine, it is the area within the solvent cleaning machine that extends from the solvent/air interface to the bottom of the entrance or exit opening, whichever is lower.
- "Freeboard Height" means; for a batch cleaning machine, the distance from the solvent/air interface as measured during the idling mode or the top of the solvent drain of a remote reservoir cold cleaning machine to the top of the cleaning machine; for an in-line cleaning machine, it is the distance from the solvent/air interface to the bottom of the entrance or exit opening, whichever is lower as measured during the idling mode.
- "Freeboard Ratio" means the ratio of the solvent cleaning machine freeboard height to the smaller interior dimension (length, width, or diameter) of the solvent cleaning machine.
- "Freeboard Refrigeration Device (Also Called a 'Chiller')" means a secondary cooling coil mounted above the primary condenser that provides a chilled air blanket above the solvent vapor air-interface to cause the condensation of additional solvent vapor. A primary condenser capable of meeting the requirements of Section J.9.a or L.10.a is defined as both a freeboard refrigeration device and a primary condenser for the purposes of this rule.
- "Gas-Path Solvent Cleaner" means a solvent cleaning machine (including ancillary equipment) that applies solvent to the interior of a gas turbine or jet engine for the removal of corrosion or combustion deposits.
- "General Work Surface" means an area of a medical device or pharmaceutical facility where solvent cleaning is performed on work surfaces including, but not limited to, tables, countertops, and laboratory benches. General work surface shall not include items defined under janitorial cleaning.
- "Guillotine Cover" means a cover that is biparting and moves in the same plane.
- "Halogenated Hazardous Air Pollutant Solvent" means methylene chloride (Chemical Abstracts Service No. 75-09-2), perchloroethylene (Chemical Abstracts Service No. 127-18-4), trichloroethylene (Chemical Abstracts Service No. 79-01-6), 1,1,1-trichloroethane (Chemical Abstracts Service No. 71-55-6), carbon tetrachloride (Chemical Abstracts Service No. 56-23-5), and chloroform (Chemical Abstracts Service No. 67-66-3).
- "High-Precision Optics" means any optical element used in an electro-optical device that is designed to sense, detect, or transmit light energy, including specific wavelengths of light energy and changes in light energy levels.
- "High Volatility Solvent" means any solvent that is not classified as a low volatility solvent.

- "Hoist" means a mechanical device that carries the parts basket and the parts to be cleaned from the loading area into the solvent cleaning machine and to the unloading area at a controlled speed. A hoist may be operated by controls or may be programmed to cycle parts through the cleaning cycle automatically.
- "Idling Mode" means the time period when a solvent cleaning machine is not actively cleaning parts and the sump heating coils, if present, are turned on.
- "Initial Boiling Point" means the boiling point of a liquid as defined by ASTM D 1078-05, "Standard Test Method for Distillation Range of Volatile Organic Liquids," ASTM International.
- "In-Line Cleaning Machine" or "Continuous Cleaning Machine" means any solvent cleaning machine that uses an automated parts handling system, typically a conveyor, to automatically provide a continuous supply of parts to be cleaned. These units are fully enclosed except for the conveyor inlet and exit portals. In-line cleaning machines can be either cold or vapor cleaning machines.
- "Lip Exhaust" means a device installed at the top of the opening of a solvent cleaning machine that draws in air and solvent vapor from the freeboard area and ducts the air and vapor away from the solvent cleaning machine.
- "Liquid Leak" means any solvent leak at a rate of more than three drops per minute or any visible liquid mist.
- **"Low Volatility Solvent"** means a solvent with an initial boiling point that is greater than 120 degrees Celsius (248 degrees Fahrenheit) and with a temperature, as used, at least 100 degrees Celsius (212 degrees Fahrenheit) below the initial boiling point.
- "Maintenance Cleaning" means a solvent cleaning operation or activity carried out to keep clean general work areas where manufacturing or repair activity is performed, to clean tools, machinery, molds, forms, jigs, and equipment. This definition does not include the cleaning of adhesive, coating, or ink application equipment.
- "Manufacturing Process" means the process of making goods or articles by hand or by machinery.
- **"Medical Device"** means an instrument, apparatus, implement, machine, contrivance, implant, in vitro reagent or other similar article, including any component, accessory, raw material, partial or completed fabricated part, that meets one of the following conditions:
 - 1. It is intended for use in the diagnosis of disease or other conditions, or in the cure, mitigation, treatment, or prevention of disease; or
 - 2. It is intended to affect the structure or any function of the body; or
 - 3. It is defined in the National Formulary or the United States Pharmacopeia, or any supplement to them.
- "Mixer" means any device that mechanically agitates the liquid solvent to enhance the cleaning process.
- "Nonabsorbent Container" means any container made of nonporous material, which does not allow the migration of the liquid solvent through it.
- "Nonatomized Solvent Flow" means the use of a solvent in the form of a liquid stream without atomization.
- "Nonleaking Container" means a container without any liquid leaks.
- "Open-Top Vapor Cleaning Machine" means a batch solvent cleaning machine that has its upper surface open to the air and boils solvent to create solvent vapor used to clean and/or dry parts.
- "Primary Condenser" see "Condenser."

"Radiation-Effect Coating" means a material that prevents radar detection.

"Reactive Organic Compound Composite Partial Pressure" means the sum of the partial pressures of compounds defined as reactive organic compounds. Reactive organic compound composite pressure shall be calculated as follows:

$$\text{PP}_{\text{C}} = \frac{\sum_{i=1}^{n} \left(\text{W}_{i} \right) \left(\text{VP}_{i} \right) \left(\text{MW}_{i} \right)}{\left(\text{W}_{W} \right) + \sum_{e=1}^{n} \left(\text{W}_{e} \right) + \sum_{i=1}^{n} \left(\text{W}_{i} \right) \left(\text{MW}_{i} \right)}$$

Where:

W_i = Weight of the 1th reactive organic compound, in grams

 W_w = Weight of water, in grams

W_e = Weight of the 'eth exempt organic compound, in grams

MW_i = Molecular weight of the '9th reactive organic compound, in grams per grams-mole

MW_w = Molecular weight of water, in grams per grams-mole

MW_e = Molecular weight of the "eth exempt compound, in grams per grams-mole

PP_c = Reactive organic compound composite partial pressure at 20 degrees Celsius, in millimeters of

mercury

VP_i = Vapor pressure of the 1th reactive organic compound at 20 degrees Celsius, in millimeters of

mercury

"Refrigerated Freeboard Chiller" see the definition for Freeboard Refrigeration Device (also called a 'Chiller')."

"Remote Reservoir Cold Cleaning Machine" means any device in which liquid solvent is pumped to a sink-like work area that drains solvent back into an enclosed container while parts are being cleaned, allowing no solvent to pool in the work area. A remote reservoir cold cleaning machine that uses an enclosed container that is accessible for dipping or soaking parts is also considered to be a batch cleaning machine.

"Repair Cleaning" means a solvent cleaning operation or activity carried out during a repair process.

"Repair Process" means the process of returning a damaged object or an object not operating properly to good condition.

"Research and Development Activities" means activities conducted at a research or laboratory facility whose primary purpose is to conduct research and development into new processes and products, where such source is operated under the close supervision of technically trained personnel and is not engaged in the manufacture of products for sale or exchange for commercial profit, except in a de minimis manner.

"Rotating Basket" means a perforated or wire mesh cylinder containing parts to be cleaned that is slowly rotated while proceeding through the solvent cleaning machine.

"Scientific Instrument" means an instrument (including the components, assemblies, and subassemblies used in their manufacture) and associated accessories and reagents that is used for the detection, measurement, analysis, separation, synthesis, or sequencing of various compounds.

"Semiconductor Manufacturing" means any process or operation producing semiconductor material, slicing or polishing semiconductor material, utilizing photoresist to manufacture intermediate products, or producing either semiconductor devices or related solid state devices.

- "Silicone Manufacturing" means any process or operation producing a silicone raw material (e.g., polymer, fluid, gum, gel, elastomer, dispersion, or other bulk state silicone material). Silicone manufacturing also includes any on site preliminary processes or operations that occurs before a silicone raw material is produced.
- "Soils" mean contaminants that are removed from the part or parts being cleaned. Soils include, but are not limited to, grease, oils, waxes, metal chips, carbon deposits, fluxes, and tars.
- "Solvent/Air Interface" means, for a vapor cleaning machine, the location of contact between the concentrated solvent vapor layer and the air. This location of contact is defined as the mid-line height of the primary condenser coils. For a cold cleaning machine, it is the location of contact between the liquid solvent and the air.
- "Solvent/Air Interface Area" means; for a vapor cleaning machine, the surface area of the solvent vapor zone that is exposed to the air; for an in-line cleaning machine, it is the total surface area of all the sumps; for a cold cleaning machine, it is the surface area of the liquid solvent that is exposed to the air, except for remote reservoir cleaning machines, in which case it is the area of the drain.
- "Solvent Container" means that part of the solvent cleaning machine that is intended to hold the cleaning solvent.
- **"Solvent Vapor Zone"** means; for a vapor cleaning machine, the area that extends from the liquid solvent surface to the level that solvent vapor is condensed. This condensation level is defined as the midline height of the primary condenser coils.
- "Space Vehicle" means a vehicle designed to travel beyond the earth's atmosphere.
- "Space Vehicle Component" means any raw material, partial or completed fabricated part, assembly of parts, or completed unit of any space vehicle, including mockups and prototypes.
- "Spray Pump Control Switch" means a safety switch that prevents the spray pump from operating if the vapor level falls below the design operating level.
- "Sump" means the part of a solvent cleaning machine where the liquid solvent is located.
- "Sump Heater Coils" mean the heating system on a cleaning machine that uses steam, electricity, or hot water to heat or boil the liquid solvent.
- "Superheated Vapor System" means a system that heats the solvent vapor, either passively or actively, to a temperature above the solvent's initial boiling point. Parts are held in the superheated vapor before exiting the machine to evaporate the liquid solvent on them. Hot vapor recycle is an example of a superheated vapor system.
- "Superheated Vapor Zone" means any region located within the vapor zone of a vapor cleaning machine whereby solvent vapors are heated above the solvent's initial boiling point.
- "Ultrasonics" means enhancement of the cleaning process by agitation of liquid solvents with high frequency sound wave vibrations.
- "Vapor Cleaning Machine" means a batch or in-line solvent cleaning machine that boils liquid solvent generating solvent vapor that is used as a part of the cleaning or drying cycle.
- "Waste Solvent Residue" means sludge that may contain dirt, oil, metal particles, and/or other undesirable waste products concentrated after heat distillation of the waste solvent either in the solvent cleaning machine itself or after distillation in a separate still.

"Water Layer" means a layer of water that floats above the denser solvent and provides control of solvent emissions. In many cases, the solvent used in batch cold cleaning machines is sold containing the appropriate amount of water to create a water cover.

"Workload" means the objects put in a solvent cleaning machine for the purpose of removing oil, grease, soil, coating, dirt, moisture, or other undesirable matter from the surface of the objects.

"Workload Area" means:

- (1) The plane geometric surface area of the top of the submerged parts basket, or
- (2) The combined plane geometric surface area(s) displaced by the submerged workload, if no basket is used.
- **D. General Operating Requirements.** Any person who owns, operates, or uses any solvent cleaning machine or performs any solvent cleaning shall ensure such operation conforms to the following requirements:
 - 1. All solvent, including waste solvent and waste solvent residue, and waste solvent cleaning materials such as cloth, paper, etc. shall be stored or disposed of in nonabsorbent and nonleaking containers equipped with tight-fitting covers. The covers shall be in place unless adding material to or removing material from the containers, the containers are empty, or doing maintenance/inspection of the containers. After distillation recovery of waste solvent, solvent residues shall not contain more than 20 percent of reactive organic compound by weight.
 - 2. The solvent cleaning machine, ventilation system, and/or emission control equipment shall be installed, operated, and maintained consistent with the manufacturer's specifications.
 - 3. The cleaning of porous or absorbent materials, such as cloth, leather, wood, or rope, is prohibited. This provision shall not apply to paper gaskets, paper filters, and medical devices.
 - 4. All containers holding solvent shall be free of liquid leaks. Solvent cleaning machine equipment, such as covers, pumps, water separators, steam traps, or distillation units shall not have any liquid leaks, visible tears, holes, or cracks. Any such liquid leak, visible tear, hole, or crack that is detected shall be repaired within one day from discovery, or the solvent cleaning machine shall be drained of all solvent, consistent with Section D.12 provisions, and shut down until replaced or repaired. Solvent cleaning machines shall not be operated when leaking.
 - 5. Covers and other closure devices (e.g., valves or drain plugs) designed to reduce solvent evaporation shall not be removed or opened except to process work or to perform monitoring, inspections, maintenance, or repairs that require the removal of the covers or other closure devices. Solvent cleaning machines shall not be operated when performing maintenance or repairs.
 - 6. For solvent cleaning machine operations other than gas-path solvent cleaners and continuous web cleaning machines, solvent carry-out shall be minimized by the following methods, as applicable:
 - a. Except for remote reservoir cold cleaning machines, the workload shall be racked.
 - b. Parts having cavities, holes, or blind holes shall be tipped or rotated before being removed from the solvent cleaning machine such that the solvent in the cavities, holes, or blind holes is returned to the solvent container.
 - c. The workload shall be drained within the freeboard area so that the drained solvent is returned to the solvent container.
 - d. For cold solvent cleaning, parts shall be drained immediately after cleaning, until one of the following conditions exists:

- 1) At least 15 seconds have elapsed; or
- 2) Dripping of solvent ceases; or
- 3) The parts become visibly dry.
- e. For automated parts handling systems, the workload shall be moved in and out of the solvent cleaning machine at less than 3.4 meters per minute (11.2 feet per minute).
- 7. For solvent cleaning machine operations other than gas-path solvent cleaners and continuous web cleaning machines, solvent flow shall be directed downward to avoid turbulence at the solvent/air interface and to prevent liquid solvent from splashing outside of the solvent cleaning machine. If a flexible hose or flushing device is used, flushing shall be performed only within the freeboard area of the solvent cleaning machine.
- 8. For solvent cleaning machine operations other than gas-path solvent cleaners, solvent flow shall not be used in a manner such that liquid solvent splashes outside the container.
- 9. Solvent shall not be atomized unless it is vented to an emission control system that meets the requirements of Section N.
- 10. Any solvent spills shall be wiped up immediately and the used absorbent material (e.g., cloth, paper, sand, sawdust, etc.) shall be stored in closed containers that are handled in accordance with Section D.1.
- 11. Solvent levels shall not exceed the solvent cleaning machine's fill line.
- 12. Draining or filling solvent containers shall be performed at a level lower than the liquid solvent surface.
- 13. When using a ventilation fan, it shall not be positioned in such a way as to direct air flow near a solvent cleaning machine opening.
- E. Additional Operating Requirements for Batch Vapor Cleaning Machines and In-Line Vapor Cleaning Machines. Any person who owns, operates, or uses any batch vapor cleaning machine or any inline vapor cleaning machine shall ensure the equipment operation conforms to the following requirements:
 - 1. Except to perform monitoring, inspections, maintenance, or repairs that require the removal of the covers:
 - a. Idling mode covers shall be closed or in place when the equipment is in an idling mode.
 - b. Downtime mode covers shall be closed or in place when the equipment is in a downtime mode.
 - 2. When starting the solvent cleaning machine, the primary condenser shall be turned on before the sump heater.
 - 3. When shutting down the solvent cleaning machine, the sump heater shall be turned off and the solvent vapor layer allowed to collapse before the primary condenser is turned off.
 - 4. The workload shall be cleaned in the vapor zone for at least 30 seconds or until condensation ceases.
 - 5. Parts shall be allowed to dry within the solvent cleaning machine until the exterior surface of the parts become visually dry.
 - 6. Solvent spray shall be kept at least 10 centimeters (3.94 inches) below the solvent/air interface.

- 7. The workload area shall not occupy more than half of the solvent/air interface area of the solvent cleaning machine.
- 8. For solvent cleaning machines equipped with water separators, water shall not be visibly detectable in the solvent phase exiting the water separator, nor shall solvent be visibly detectable in the aqueous phase leaving the separator.
- 9. If equipped with a superheated vapor zone:
 - a. The manufacturer's specifications for determining the minimum proper dwell time within the superheated vapor system shall be followed.
 - Parts and parts baskets shall remain in the vapor zone for at least the minimum proper dwell time.
 - c. The temperature within the superheated vapor zone shall be at least 10 degrees Fahrenheit above the initial boiling point of the solvent being used.
- **F.** Additional Operating Requirements for Gas-Path Solvent Cleaners. Any person who owns, operates, or uses any gas-path solvent cleaner shall ensure the equipment operation conforms to the following requirements:
 - 1. Cleaned parts or equipment shall be drained until dripping ceases or 15 seconds have elapsed.
 - 2. The cover of the solvent container(s), reservoir(s) and opening(s) of a solvent collection system shall be closed at all times except to process work or to perform monitoring, inspections, maintenance, or repairs that require the removal of the covers or other closure devices.
- **G. General Equipment Requirements for Solvent Cleaning Machines.** Any person who owns, operates, or uses any solvent cleaning machine shall ensure that it is equipped with the following:
 - 1. A container for the solvent.
 - 2. Except for remote reservoir cold cleaning machines using low volatility solvents, an apparatus or cover(s) to completely cover the solvent container when not processing work.
 - 3. Except for gas-path solvent cleaners using a solvent with a reactive organic compound content of 50 grams per liter of material or less, an apparatus or a device for draining cleaned parts such that the drained solvent or drag-out is returned to the solvent container.
 - 4. A list of the applicable operating requirements. At a minimum, the list shall include the applicable operating requirements contained in Sections D, E, and F. The list of operating requirements shall be legible and conspicuously posted or maintained on or near the equipment in such a manner that it is conveniently available to the operator for reference purposes.
 - 5. Where solvent agitation is used, equipment that achieves agitation by use of pump recirculation, mechanical mixing (a mixer), or ultrasonics. Gas or air agitation shall not be used. When a pumpagitated solvent bath is used, the pump agitator shall be designed to produce a rolling motion of the solvent without any observable splashing against tank walls or parts being cleaned.
 - 6. When employing solvent flow, a flexible hose or flushing device that produces only a continuous fluid stream. An atomized or shower type spray shall not be used unless it is used in an in-line or enclosed solvent cleaning machine where the spray is conducted in a totally confined space that is sealed from the atmosphere.
 - 7. Where a hood, enclosure, lip exhaust, or a lip exhaust connected to a hood or enclosure is employed, a blower or fan such that the air ventilation rate shall not exceed 20 cubic meters per

- minute per square meter (65.6 cubic feet per minute per square feet) of solvent/air interface area, unless necessary to meet a National Institute for Occupational Safety and Health standard.
- 8. When a lip exhaust is installed or added after July 17, 1997, an emission control system that meets the requirements of Section N.
- 9. A workroom having an average draft rate, as measured parallel to the plane of the solvent cleaning machine opening, not exceeding 9.1 meters per minute (30 feet per minute), unless necessary to meet a National Institute for Occupational Safety and Health standard.
- When employing an automated parts handling system, equipment such that the speed of the parts shall not exceed 3.4 meters per minute (11.2 feet per minute).
- **H.** Additional Equipment Requirements for Remote Reservoir Cold Cleaning Machines. Any person who owns, operates, or uses any remote reservoir cold cleaning machine shall ensure that it is equipped with the following:
 - 1. A sink or work area that is sloped sufficiently towards the drain to prevent pooling of solvent.
 - 2. A single drain hole, not larger than 100 square centimeters (15.5 square inches) in area, for the solvent to flow from the sink into the enclosed reservoir.
 - 3. Except when using low volatility solvents, a cover or a device, such as a valve or a drain plug, to prevent or minimize solvent vapor emissions from the solvent container when not processing work or performing monitoring, inspections, maintenance, or repairs that require the removal of the cover or device.
 - 4. A freeboard height of 6 inches or higher.
 - 5. When the solvent is heated above 50 degrees Celsius (122 degrees Fahrenheit), or it is agitated, or the solvent is a high volatility solvent, dimensions such that the freeboard ratio is 0.75 or greater.
 - 6. In lieu of the freeboard height required by Section H.4 or the freeboard ratio required by Section H.5, one of the following requirements may be met:
 - a. A water layer at a minimum thickness of 2.5 centimeters (1.0 inch) on the surface of the solvent within the cleaning machine shall be used, or
 - b. An emission control system that meets the requirements of Section N shall be used.
 - 7. Effective [one year from the date of revised rule adoption], except when using an emission control system that meets the requirements of Section N, solvent that contains 50 grams of reactive organic compound per liter of material or less.
- I. Additional Equipment Requirements for Batch Cold Cleaning Machines. Any person who owns, operates, or uses any batch cold cleaning machine other than a remote reservoir cold cleaning machine shall ensure that it is equipped with the following:
 - 1. When using a high volatility solvent, a cover that is a sliding, rolling, or guillotine type that is designed to easily open and close. If a mechanized batch cold cleaning machine (e.g., a manually loaded or semi-continuously loaded Ferris wheel or cross-rod solvent cleaning machine) is used with a high volatility solvent, the unit shall be equipped with a downtime mode cover.
 - 2. If using a high volatility solvent, the drainage apparatus or device required by Section G.3 shall be internal so that the cleaned parts are within the solvent cleaning machine and under the cover while draining. The drainage apparatus or device may be external where the internal type cannot fit into the cleaning system provided the drained solvent is returned to the solvent container.

- 3. When using a low volatility solvent that is not agitated, a freeboard height of 6 inches or higher or dimensions such that the freeboard ratio is 0.5 or greater.
- 4. When the solvent is heated above 50 degrees Celsius (122 degrees Fahrenheit), or it is agitated, or the solvent is a high volatility solvent, dimensions such that the freeboard ratio is 0.75 or greater.
- 5. In lieu of the freeboard height or freeboard ratio required by Section I.3 or the freeboard ratio required by Section I.4, one of the following requirements may be met:
 - a. A water layer at a minimum thickness of 2.5 centimeters (1.0 inch) on the surface of the solvent within the cleaning machine shall be used, or
 - b. An emission control system shall be used that meets the requirements of Section N shall be used.
- 6. A conspicuous mark denoting the maximum allowable solvent level conforming to the applicable freeboard requirements. This requirement does not apply if employing a water layer or an emission control system per Section I.5.
- 7. Effective [one year from the date of revised rule adoption], except when using an emission control system that meets the requirements of Section N, solvent that contains 50 grams of reactive organic compound per liter of material or less.
- **J.** Additional Equipment Requirements for Batch Vapor Cleaning Machines. Any person who owns, operates, or uses any batch vapor cleaning machine shall ensure that it is equipped with the following:
 - 1. For open-top vapor cleaning machines, a cover that is a sliding, rolling, or guillotine type that is designed to easily open and close without disturbing the vapor zone. This requirement does not apply to open-top vapor cleaning machines equipped with top enclosures, provided:
 - a. the operator only opens the enclosure cover(s) or door(s) when the condenser is operative or when the solvent cleaning machine is shut down, and
 - b. the solvent cleaning machine solvent/air interface area is less than 1 square meter (10.8 square feet), and
 - c. the solvent cleaning machine cover is designed such that it can be opened and closed easily without disturbing the vapor zone.
 - For mechanized batch vapor cleaning machines (e.g., a manually-loaded or semi-continuously-loaded Ferris wheel or cross-rod solvent cleaning machine), idling and downtime mode covers.
 - 3. A primary condenser situated above the boiling solvent.
 - 4. A condenser flow switch that automatically shuts off the sump heater if the condenser coolant stops circulating or becomes warmer than its designed operating temperature.
 - 5. A vapor level control device that automatically shuts off the sump heater if the vapor level in the vapor cleaning machine rises above the height of the primary condenser.
 - 6. For solvent cleaning machines with solvent flow, a device such as a spray pump control switch that prevents the solvent flow pump operation unless the solvent vapor level is at the designed operating level.
 - 7. A device that automatically shuts off the sump heat if the sump liquid solvent level drops to the sump heater coils.

- 8. Dimensions such that the freeboard ratio is 0.75 or greater. Effective [one year from the date of revised rule adoption], the unit shall have dimensions such that the freeboard ratio is 1.0 or greater.
- 9. For solvent cleaning machines with a solvent/air interface area of 1 square meter (10.8 square feet) or greater:
 - a. A freeboard refrigeration device for which the chilled air blanket temperature (expressed in degrees Fahrenheit) at the coldest point on the vertical axis in the center of the air blanket shall be no greater than 30 percent of the initial boiling point (expressed in degrees Fahrenheit) of the solvent used or no greater than 40 degrees Fahrenheit. If the chiller operates below 32 degrees Fahrenheit, it shall be equipped with an automatic defrost; or
 - b. An enclosed design in which the cover or door opens only when the dry part is actually entering or exiting the solvent cleaning machine.
- 10. In lieu of the freeboard ratio required by Section J.8 or the freeboard chiller/enclosed design required by Section J.9, an emission control system that meets the requirements of Section N may be used.
- 11. Effective [one year from the date of revised rule adoption], except when an emission control system that meets the requirements of Section N is employed, when using solvent containing in excess of 50 grams of reactive organic compound per liter of material:
 - a. An automated parts handling system;
 - b. A circumferential trough;
 - c. A water separator (not required for solvents that form azeotropes with water);
 - d. A freeboard refrigeration device that is operated such that the chilled air blanket temperature, measured at the center of the air blanket, is no greater than 40 percent of the initial boiling point of the solvent, in degrees Fahrenheit, for solvents that do not form azeotropes with water, or 50 percent of the initial boiling point, in degrees Fahrenheit, for solvents that form azeotropes with water; and
 - e. A superheated vapor zone where parts remain in the vapor zone for at least the minimum dwell time, as specified by the manufacturer. The temperature within the superheated vapor zone shall be at least 10 degrees Fahrenheit above the initial boiling point of the solvent being used.
- **K.** Additional Equipment Requirements for In-Line Cold Cleaning Machines. Any person who owns, operates, or uses any batch in-line cold cleaning machine shall ensure that it is equipped with the following:
 - 1. A rotating basket, tumbling basket, drying tunnel, or other means that prevents cleaned parts from carrying out solvent liquid or vapor.
 - 2. Openings such that the average clearance between workload material and the edges of the solvent cleaning machine entrance and exit openings shall be less than 10 centimeters (3.94 inches) or less than 10 percent of the opening width, whichever is less.
 - 3. Downtime mode covers. A continuous web part that completely occupies an entry and exit port when the machine is idle is considered to meet this requirement.
 - 4. Dimensions such that the freeboard ratio is 0.75 or greater.

- 5. In lieu of the freeboard ratio required by Section K.4, an emission control system that meets the requirements of Section N may be used.
- 6. Effective [one year from the date of revised rule adoption], except when using an emission control system that meets the requirements of Section N, solvent that contains 50 grams of reactive organic compound per liter of material or less.
- **L.** Additional Equipment Requirements for In-Line Vapor Cleaning Machines. Any person who owns, operates, or uses any in-line vapor cleaning machine shall ensure that it is equipped with the following:
 - 1. A rotating basket, tumbling basket, drying tunnel, or other means that prevents cleaned parts from carrying out solvent liquid or vapor.
 - 2. Openings such that the average clearance between workload material and the edges of the solvent cleaning machine entrance and exit openings shall be less than 10 centimeters (3.94 inches) or less than 10 percent of the opening width, whichever is less.
 - 3. Idling and downtime mode covers. A continuous web part that completely occupies an entry and exit port when the machine is idle is considered to meet this requirement.
 - 4. A primary condenser situated above the boiling solvent.
 - 5. A condenser flow switch that automatically shuts off the sump heater if the condenser coolant stops circulating or becomes warmer than its designed operating temperature.
 - 6. A vapor level control device that automatically shuts off the sump heater if the vapor level in the vapor cleaning machine rises above the height of the primary condenser.
 - 7. For solvent cleaning machines with solvent flow, a device such as a spray pump control switch that prevents the solvent flow pump operation unless the solvent vapor level is at the designed operating level.
 - 8. A device that automatically shuts off the sump heat if the sump liquid solvent level drops to the sump heater coils.
 - 9. Dimensions such that the freeboard ratio is 0.75 or greater. Effective [one year from the date of revised rule adoption], the unit shall have dimensions such that the freeboard ratio is 1.0 or greater.
 - 10. In lieu of the freeboard ratio required by Section L.9, one of the following may be met:
 - a. A freeboard refrigeration device for which the chilled air blanket temperature (expressed in degrees Fahrenheit) at the coldest point on the vertical axis in the center of the air blanket shall be no greater than 30 percent of the initial boiling point (expressed in degrees Fahrenheit) of the solvent used or no greater than 40 degrees Fahrenheit. If the chiller operates below 32 degrees Fahrenheit, it shall be equipped with an automatic defrost; or
 - b. An emission control system that meets the requirements of Section N shall be used.
 - 11. Effective [one year from the date of revised rule adoption], except when an emission control system that meets the requirements of Section N is employed, when using solvent containing in excess of 50 grams of reactive organic compound per liter of material:
 - a. A circumferential trough;
 - b. A water separator (not required for solvents that form azeotropes with water);

- c. A freeboard refrigeration device that is operated such that the chilled air blanket temperature, measured at the center of the air blanket, is no greater than 40 percent of the initial boiling point of the solvent, in degrees Fahrenheit, for solvents that do not form azeotropes with water, or 50 percent of the initial boiling point, in degrees Fahrenheit, for solvents that form azeotropes with water; and
- d. A superheated vapor zone where parts remain in the vapor zone for at least the minimum dwell time, as specified by the manufacturer. The temperature within the superheated vapor zone shall be at least 10 degrees Fahrenheit above the initial boiling point of the solvent being used.

M. Requirements - Solvent Cleaning.

Section M requirements apply to any person performing solvent cleaning, including, but not limited to, use of wipe cleaning cloths, cotton swabs, dabber bottles, hand-held spray bottles, squirt bottles, aerosol products, and the cleaning of application equipment. The following requirements become effective [one year from the date of revised rule adoption] and are in addition to the general operating requirements specified in Section D.

1. **Solvent Requirements.** Except when using an emission control system that meets the requirements of Section N, no person shall use any solvent to perform solvent cleaning which exceeds the applicable grams of reactive organic compound per liter of material limit specified in Table 1.

Table 1: Reactive Organic Compound Content Limits for Solvent Cleaning

SOLVENT CLEANING ACTIVITY	ROC Limit, grams of ROC per liter of material (pounds of ROC per gallon ^a)
(a) Product Cleaning During Manufacturing Processes and Surface Application:	Preparation for Coating
(i) General	50 (0.42)
(ii) Electrical Apparatus Components & Electronic Components	900 (7.51)
(iii) Medical Devices & Pharmaceuticals	900 (7.51)
(iv) Silicone Manufacturing	900 (7.51)
(b) Repair Cleaning and Maintenance Cleaning:	, ,
(i) General	50 (0.42)
(ii) Electrical Apparatus Components & Electronic Components	900 (7.51)
(iii) Medical Devices & Pharmaceuticals:	
(I) Tools, Equipment, & Machinery	900 (7.51)
(II) General Work Surfaces	900 (7.51)
(iv) Silicone Manufacturing	900 (7.51)

^a English units are provided for information only.

SOLVENT CLEANING ACTIVITY	ROC Limit, grams of ROC per liter of material (pounds of ROC per gallon ^a)
(c) Cleaning of Coatings Application Equipment	950 (7.93)
(d) Cleaning of the Following Items and Equipment and their Components: (i) Aerospace Vehicles; (ii) Aerospace Vehicle Payloads and Satellites; (iii) Aerospace Vehicle, Aerospace Vehicle Payload, and Satellite: (I) Transport Equipment (e.g., railcars, trucks, trailers, forklifts, and containers), and (II) Support Processing Equipment (e.g., clean rooms, tools, payload fairing fixtures, alignment jigs, fuel and oxidizer loading carts and associated transfer lines).	900 (7.51)

- 2. **Cleaning Devices and Methods.** Except for solvent cleaning of spray application equipment, any person performing solvent cleaning with a solvent containing more than 50 grams per liter of material shall use one or more of the following cleaning devices or methods:
 - Wipe cleaning where solvent is dispensed to wipe cleaning materials from containers that are kept closed to prevent evaporation, except while dispensing solvent or replenishing the solvent supply;
 - b. Application of solvent from hand-held spray bottles, squirt bottles, or other closed containers with a capacity of one liter or less; or
 - c. Non-atomized solvent flow, dip, or flush method where pooling on surfaces being cleaned is prevented or drained, and all solvent runoff is collected in a manner that enables solvent recovery or disposal. The collection system shall be kept closed to prevent evaporation except while collecting solvent runoff or emptying the collection system.
- 3. **Solvent Cleaning of Spray Application Equipment.** Any person cleaning spray application equipment with a solvent containing more than 50 grams of reactive organic compound per liter of material shall use an enclosed system, or equipment that is proven to the satisfaction of the Control Officer to be equally effective as an enclosed system at controlling emissions. If an enclosed system is used, it shall totally enclose spray guns, cups, nozzles, bowls, and other parts during washing, rinsing and draining procedures, and it shall be used according to the manufacturer's recommendations and be closed when not in use.
- N. Emission Control System Requirements. Any person who owns, operates, or uses any emission control system required by Sections D.9, G.8, or T.2.b.4) or as an alternative compliance method as provided for in this rule shall ensure that the following requirements are met:
 - 1. The overall efficiency (the capture system efficiency multiplied by the emission control device efficiency) of the total system shall not be less than 85 percent by weight in reducing total reactive organic compound and toxic air contaminant emissions.

- 2. When using a carbon adsorber, the system exhaust shall be no more than 25 parts per million of reactive organic compound by volume, calculated as carbon, over a complete adsorption cycle,
- 3. The emission collection system shall have a ventilation rate between 15 to 20 cubic meters per minute per square meter of solvent/air interface area (49.2 to 65.6 cubic feet per minute per square feet of solvent air interface area), unless otherwise required to meet a National Institute for Occupational Safety and Health standard.
- 4. An application for installation of the emission control equipment is submitted and the Control Officer grants an Authority to Construct for the equipment.
- 5. An initial source test is accomplished by [one year from the date of revised rule adoption] or a later deadline established in an Authority to Construct to demonstrate compliance with the overall efficiency of the total system and/or the 25 parts per million reactive organic compound by volume limits of this rule.
- 6. Compliance through the use of an emission control system will not result in reactive organic compound emissions in excess of the reactive organic compound emissions which would result from compliance with Sections H.7, I.7, K.6, or M.1.
- O. Alternative Operating and Equipment Requirements for an Airless Solvent Cleaning Machine or an Air-Tight Solvent Cleaning Machine. In lieu of meeting the requirements of Sections E through L, any person may use an airless solvent cleaning machine or air-tight solvent cleaning machine provided all of the following requirements are met:
 - 1. The equipment is operated in accordance with the manufacturer's specifications and operated with a door or other pressure sealing apparatus that is in place during all cleaning and drying cycles.
 - 2. No pressure relief device shall allow liquid solvent to drain out.
 - 3. A differential pressure gauge shall be installed to indicate the sealed chamber pressure.
 - 4. A list of operating requirements shall be legible and conspicuously posted or maintained on or near the equipment in such a manner that it is conveniently available to the operator for reference purposes.

P. Test Methods.

Any person who owns, operates, or uses any solvent cleaning machine or performs any solvent cleaning shall comply with the following test methods:

- 1. The reactive organic compound content of solvents shall be measured by the Environmental Protection Agency Reference Method 24 (40 CFR, Part 60, Appendix A-7).
- 2. The initial boiling point of solvents shall be determined by ASTM D 1078-05, "Standard Test Method for Distillation Range of Volatile Organic Liquids," ASTM International.
- 3. The capture system efficiency shall be determined in accordance with the Environmental Protection Agency method described in 40 CFR, §52.741(a)(4)(iii) when the emission control system is used for reducing emissions of reactive organic compounds. For emission control systems handling compounds that are toxic air contaminants but not reactive organic compounds, the capture system efficiency shall be determined by using the same aforementioned method modified in a manner approved by the Control Officer to quantify the mass of liquid or gaseous reactive organic compounds and/or toxic air contaminants.
- 4. The emission control device efficiency shall be determined pursuant to the Environmental Protection Agency method described in 40 CFR, §51, Appendix M, methods 204-204F, when the emission control system is used for reducing emissions of reactive organic compounds. For

emission control systems handling any compound that is a toxic air contaminant but not a reactive organic compound, the emission control device efficiency shall be determined using:

- a. an Environmental Protection Agency approved test method or methods, or
- b. in the case where there is no Environmental Protection Agency approved test method, a Control Officer approved detection method applicable for each target toxics specie.
- c. Several Environmental Protection Agency and/or Control Officer approved test methods on the emission control device efficiency may need to be employed to demonstrate that the emission control system overall efficiency is at least 85 percent by weight in reducing emissions of reactive organic compounds and/or toxic air contaminants. In addition, techniques to convert 'parts per million by volume' test method results to 1) 'parts per million by weight' and/or 2) 'mass emission rates' (e.g., pounds per hour) shall be approved by the Control Officer.
- 5. The volumetric flowrate shall be determined in accordance with the Environmental Protection Agency Methods 2, 2A, 2C, 2D, 2F, or 2G (40 CFR, Part 60, Appendix A-1).
- 6. The average workroom draft rate shall be measured parallel to the plane of the solvent cleaning machine opening with a thermistor anemometer with an accuracy within ± 2 feet per minute and a calibration pursuant to the National Institute of Standards and Technology.
- 7. The identity of components in solvents shall be determined using manufacturer's formulation data or by using ASTM E 168-06, 'Standard Practices for General Techniques of Infrared Quantitative Analysis," ASTM International, ASTM E 169-04, 'Standard Practices for General Techniques of Ultraviolet-Visible Quantitative Analysis," ASTM International, or ASTM E 260-96 (2006), 'Standard Practice for Packed Column Gas Chromatography," ASTM International.
- 8. Emissions of reactive organic compounds from the exhaust of an emission control system shall be measured by the Environmental Protection Agency Method 18 (40 CFR, Part 60, Appendix A-7), with gas chromatography-flame ionization detection speciation analysis for C1, C2, C3, C4, C5, C6+ species. Alternatively, the Environmental Protection Agency Method 25 or 25A in combination with Method 18 may be used.
- Q. Operation and Maintenance Plan. Any person proposing to use an emission control device to comply with this rule pursuant to Section N shall submit, with the Authority to Construct application, an emission control device Operation and Maintenance Plan to the Control Officer for approval. The Operation and Maintenance Plan shall specify:
 - 1. operation and maintenance procedures of emissions-producing operation, and
 - 2. which records shall be kept to document these operation and maintenance procedures.
 - 3. In addition, these records shall comply with the requirements of Section R.1.c and R.3. The Operation and Maintenance Plan shall be implemented upon approval of the Control Officer.

R. Recordkeeping Requirements.

- 1. Any person who owns, operates, or uses a solvent cleaning machine or performs solvent cleaning that is subject to this rule shall comply with the following requirements:
 - a. Record and maintain the following information:
 - 1) Brand name, stock identification number, and generic product class for each solvent used during the month at the stationary source.

- 2) Material safety data sheets for each material listed in response to Section R.1.a.1).
- 3) Purchase records for each material listed in response to Section R.1.a.1).
- b. Record the following information for the stationary source:
 - 1) On a monthly basis, the total monthly volume (gallons) usage and reactive organic compound content (grams per liter or pounds per gallon of reactive organic compound) for each material listed in response to Section R.1.a.1).
 - 2) Records confirming compliance with the acceptable disposal methods listed in Section D.1, each time waste solvent or waste solvent residue is removed from the stationary source for disposal.
 - For solvent cleaning, the type of cleaning activity for each solvent used at the stationary source in accordance with the cleaning categories specified in Table 1 of this rule.
 - 4) For each solvent cleaning machine:
 - i. Type of solvent cleaning machine.
 - ii. Brand name of each solvent used in the solvent cleaning machine and the reactive organic compound content of each solvent, as used.
 - iii. The solvent(s) initial boiling point.
 - 5) When the solvent used is a mixture of different materials that are blended by the operator, the mix ratio of the batch shall be recorded and the reactive organic compound content of the batch shall be calculated and recorded in order to determine compliance with the specified limits of reactive organic compound content, as applied.
- c. If using an emission control system pursuant to Section N as a means of complying with this rule, the person shall maintain such records as required by the Operation and Maintenance Plan in Section Q on a daily basis. Key operating parameters and other information necessary to verify compliance with the required overall efficiency of the total system, as specified in Section N.1, shall be recorded. These parameters shall include, but not be limited to:
 - 1) Hours of operation;
 - 2) All maintenance work that requires the emission control system to be shut down;
 - 3) All information needed to demonstrate continuous compliance with Section N, such as temperatures, pressures, and/or flow rates.
- 2. In addition to the records required by Section R.1, any person claiming the Section B.9 exemption or the Section B.15 exemption, shall maintain records in order to demonstrate compliance with the solvent usage rate aggregate limits. For Section B.9 exemption claims, daily records on a facility basis shall be maintained. For Section B.15 exemption claims, monthly and calendar year total records on a stationary source basis shall be maintained.
- 3. Maintain the records kept pursuant to this rule on site for at least 3 years. Thereafter, maintain such records either on site or readily available for expeditious inspection and review for an additional 2 years.

S. Reporting Requirements

Any person holding a permit for a solvent cleaning machine or solvent cleaning subject to the requirements of this rule shall submit an annual report to the District. At a minimum, the annual report shall contain the monthly records required by Section R.1.b.1), the annual totals based on each of the solvent's monthly data, the name and address of the Permittee, and the Permit to Operate number that the solvent cleaning machine and/or solvent cleaning is subject to. The report shall be due March 1 for the previous calendar year.

T. Compliance Schedule

Any person who owns, operates, or uses any solvent cleaning machine or performs any solvent cleaning subject to this rule shall meet the following compliance schedule:

1. New solvent cleaning machines and solvent cleaning operations:

Commencing [date of revised rule adoption], any new solvent cleaning machine shall comply with this rule the first time it is operated in the District. Also commencing [date of revised rule adoption], any new solvent cleaning shall comply with this rule the first time it is performed in the District.

2. Existing solvent cleaning machines:

- a. For any solvent cleaning machine previously subject to the Rule 321 adopted on September 18, 1997, commencing [date of revised rule adoption], the owner or operator shall ensure that the equipment complies with the applicable provisions of Rule 321. The provisions in Sections H.7, I.7, J.8, J.11, K.6, L.9, and L.11 have an effective date of [one year from the date of revised rule adoption].
- b. For any solvent cleaning machine previously exempt from the September 18, 1997 amended Rule 321 that lost its exemption by the adoption of amended Rules 102 (Definitions), 202 (Exemptions to Rule 201), and/or Rule 321 on [date of revised rule adoption], the owner or operator of such equipment shall comply with the following:
 - 1) By [30 days from the date of revised rule adoption], be in full compliance with the applicable operating requirements of Sections D, E, and F.
 - 2) By [180 days from the date of revised rule adoption], be in full compliance with the applicable recordkeeping and reporting provisions of Sections R and S.
 - 3) By [365 days from the date of revised rule adoption], be in full compliance with the applicable equipment requirements of Sections G, H, I, J. K, L, and N.
 - 4) Any lip exhaust installed after [date of revised rule adoption] shall be vented to an emission control system that meets the requirements of Section N at the time of installation, notwithstanding the date in Sections G.8 and T.2.b.3.

3. Existing solvent cleaning operations:

The owner or operator of any facility performing solvent cleaning as of [date of revised rule adoption] and subject to the requirements of this rule shall comply with the following:

- a. By [30 days from the date of revised rule adoption], be in full compliance with the applicable operating requirements of Section D.
- b. By [180 days from the date of revised rule adoption], be in full compliance with the applicable recordkeeping and reporting provisions of Sections R and S.

c. By [365 days from the date of revised rule adoption], be in full compliance with the solvent cleaning requirements of Rule Section M.

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